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QUARTERLY REPORT

**TRENDS AND TECHNIQUES FOR
SPACE BASE ELECTRONICS**

Prepared by:

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QUARTERLY REPORT
TRENDS AND TECHNIQUES FOR
SPACE BASE ELECTRONICS

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for

NASA Contract NAS8-26749

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JUN 12 1978

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1. DOUBLE-LEVEL METALLIZATION TECHNIQUES

Most of the work during the first quarter was directed toward the development of a sputtering system for preparing aluminum and aluminum-alloy films. A photograph of the completed system is shown in Figure 1.1. Briefly, the system consists of the following.

The basic vacuum system is a Varian-NRC 6 inch oil diffusion and mechanical roughing pump equipped for automatic and manual operation. The diffusion pump is equipped for LN₂ cooling of the cold trap. The sputter gun and power supply were obtained from Sloan Technology. The sputtering chamber was designed and built at Mississippi State. It consists of a Corning 12X18 glass cylinder and an aluminum top plate machined to accommodate up to three sputter guns. A cold cathode discharge gauge was constructed and installed in the baseplate of the chamber to measure the pressure during the sputtering operation. A throttle valve with several threaded holes for accommodating plugs is operated by one of two mechanical feedthroughs in the baseplate. A lift mechanism with a reversible motor was designed and constructed for raising the top plate and sputter guns.

Inside the chamber is equipped with a rotating table which accommodates up to eight wafers of 1½-2" in diameter. The table is driven by a vacuum sealed shaded pole motor through a magnetic coupling at 7 rpm. The entire motor-table assembly is rotated by a chain-sprocket-mechanical feedthrough arrangement through three sputter-gun and two mask positions. The mask is attached to the rotating assembly and provides one hole through which the sputter-gun deposits metal on the wafers. A crystal film thickness sensor is located beneath the sputter-gun and receives a deposit through a hole at an unused wafer position on the table.

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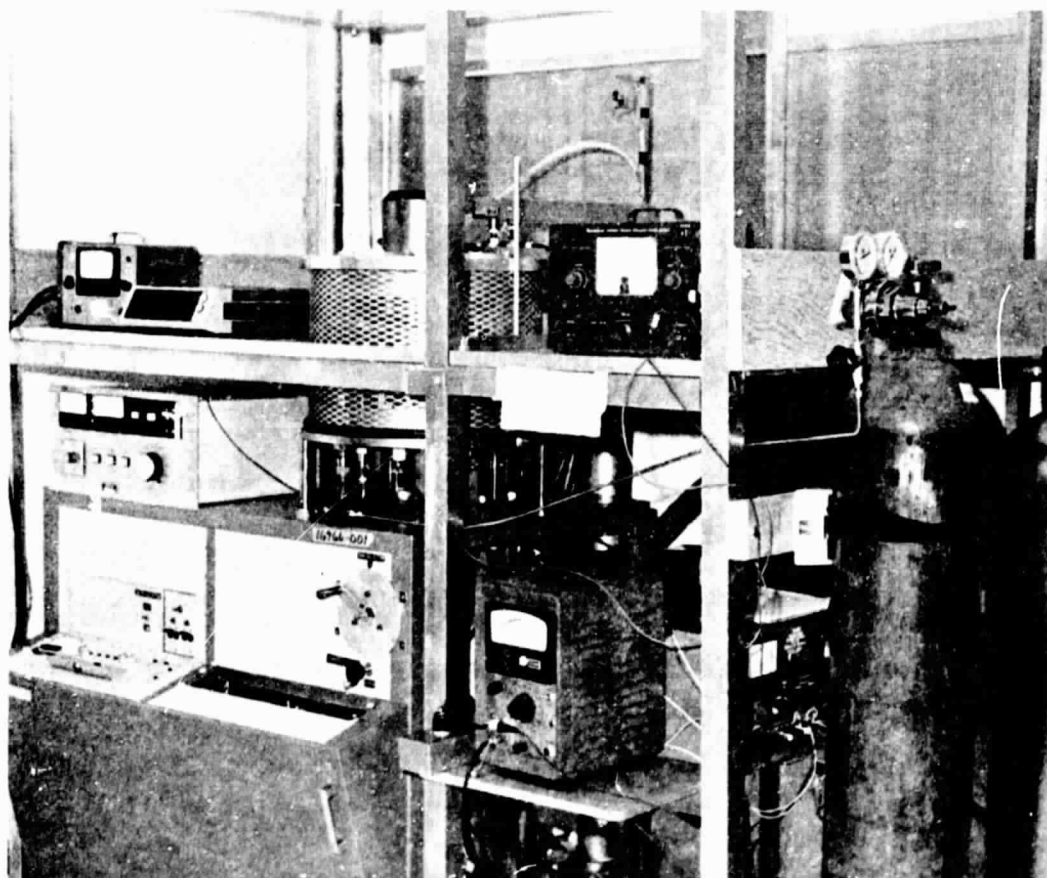


Figure 1.1 Photograph of metallization system using sputter-gun source.

The sputtering chamber opens into a class 100 clean bench in order to maintain a high level of cleanliness. The system is located in the metallizing and bonding room of the microelectronics laboratories in Simrall Engineering Building, and this room was designed with air conditioning and filtering units to maintain a class 30,000 environment. The entire system has been constructed and checked out and is ready for depositing sputtered films.

The installation of a six-tube Thermco Ranger diffusion furnace was completed with the addition of a venting system for exhausting the scavenger boxes. All that remains to be done is to line the tube and connect the nitrogen ambient source in order to anneal the aluminum films.

2. TWO-DIMENSIONAL MODELS FOR MOS TRANSISTORS

The work done during the first quarter was directed toward preliminary investigations of numerical schemes and computational algorithms for solving the semiconduction equations for a two-dimensional field.

A recent report has described the application of the finite-element method to the analysis of a JFET.¹ The finite-element method has been used for some time in solving problems in mechanics and elasticity; however, it has only recently been applied to semiconduction problems. This method has the power to treat some problems, such as eigen-value problems, for which the finite-difference method is awkward if at all applicable. It can also be applied to the solution of field distributions governed by partial differential equations, and one of the most attractive features as compared to the finite-element method is purported to be the ease of treating non-rectangular geometries and irregular boundaries. For example, the geometry of the VMOS structure could be accommodated. It was decided to further investigate this technique.

In order to better understand the applicability of the method, it was applied to a one-dimensional linear diffusion problem. This simple problem is one for which familiar results are available for comparison and at the same time taxes the finite-element method. In its most valid form, the finite element method is applicable to variational problems in which a true minimum of an energy-related function exists. Such a minimum does not apply for the semiconductor problem in which current flow occurs by diffusive and conductive mechanisms. It has been proposed that a "weak form", the so-called Galerkin method, be applied to such problems.² The typical semiconductor problem is a non-linear boundary value and initial condition problem of which the linear diffusion problem is a very special case. In the example chosen, the diffusion variable, u , obeys:

$$u(x,t)|_{x=0} = u_s = 1 \quad (a) \quad (2.1)$$

$$u_x(x,t)|_{x=a} = 0 \quad (b)$$

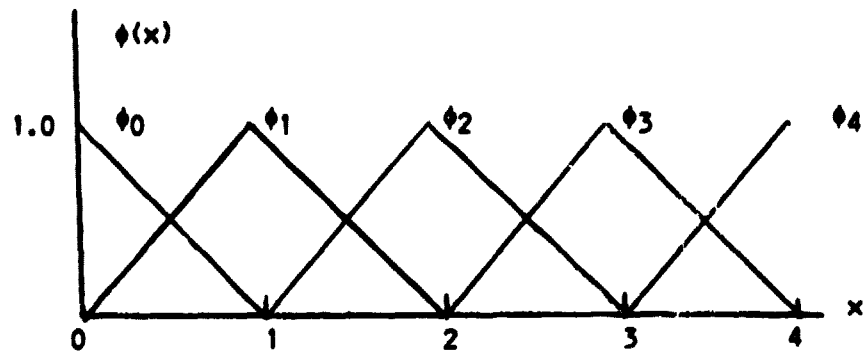
$$u(x,t)|_{t=0} = \begin{matrix} 1, & x=0 \\ 0, & x>0 \end{matrix} \quad (c)$$

$$u_t - u_{xx} = f(x,t) = 0 \quad 0 \leq x \leq a \quad (2.2)$$

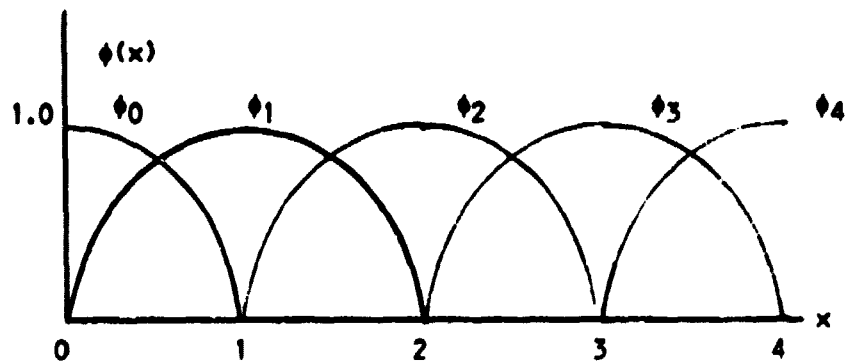
The Galerkin formulation of this problem is:

$$\int_0^a (u_t v - u_x v_x - f v) dx = 0, \quad (2.3)$$

where $v(x,t)$ represents a "trial function" which is used to approximate $u(x,t)$. The finite element method uses a set of "hill functions" as illustrated in Figure 2.1 to construct the $v(x,t)$ approximation. Two of the popular hill functions are the Hermite bicubic and the bilinear functions which are illustrated in the figure and were used in the example. The final form of the approximate solution is;



(a) Bilinear hill functions



(b) Bicubic (Hermite) hill functions

Figure 2.1 Illustration of hill functions used in finite element method.

$$v(x,t) = \sum_{i=1}^N q_i(t) \phi_i(x). \quad (2.4)$$

On the node points the solution is approximated by the set $\{q_i(t)\}$ for the type of hill functions which overlap as illustrated in Figure 2.1. Solution for the set $\{q_i(t)\}$ is then analogous to solving for the set $\{u_i(t)\}$ on the node points using the finite difference technique. The equations for the set $\{q_i(t)\}$ are obtained by substituting (2.4) into (2.3).

$$\sum_{i=1}^N \int_0^a \left(\frac{\partial q_i}{\partial t} \phi_i \phi_j + q_i \frac{\partial \phi_i}{\partial x} \frac{\partial \phi_j}{\partial x} + f \phi_j \right) dx = 0$$

$$j = 1, 2, 3, \dots, N \quad (2.5)$$

From (2.5) a set of time differential equations is obtained which is solved using an implicit numerical method.

The solution of the problem posed by the example is closely approximated by the erfc function in the range $0 \leq x \leq 3$ if $a = 6$, and this solution was used to compare the accuracy of the finite element and finite difference methods. Figures 2.2-2.4 show the maximum error as a function of the reciprocal of the number of grid points and the size of the time step, i.e. $\lambda^2 = \Delta t / \Delta x^2$.

The error obtained in the solution by the bilinear finite element method is very nearly the same as that obtained with the finite difference method. This was not surprising because the system of equations for $\{q_i(t)\}$ and $\{u_i(t)\}$ were quite similar. What was surprising was that the Hermite bicubic finite element produced such poor results, although this surprise was based upon the intuition that since this element was more difficult to use it should provide some reward for the difficulty.

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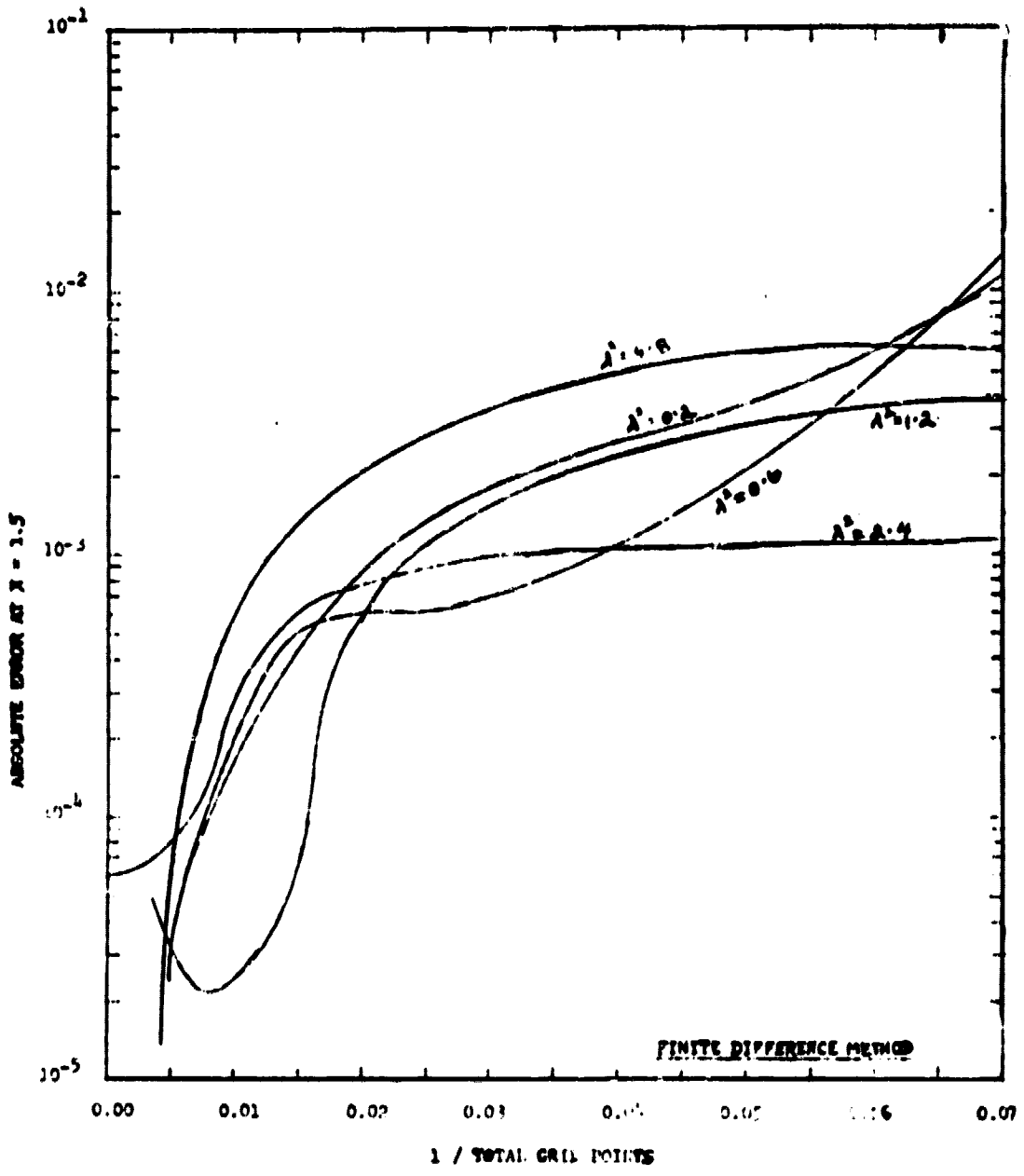


Figure 2.2 Error for finite-difference vs. reciprocal of total number of grid points,

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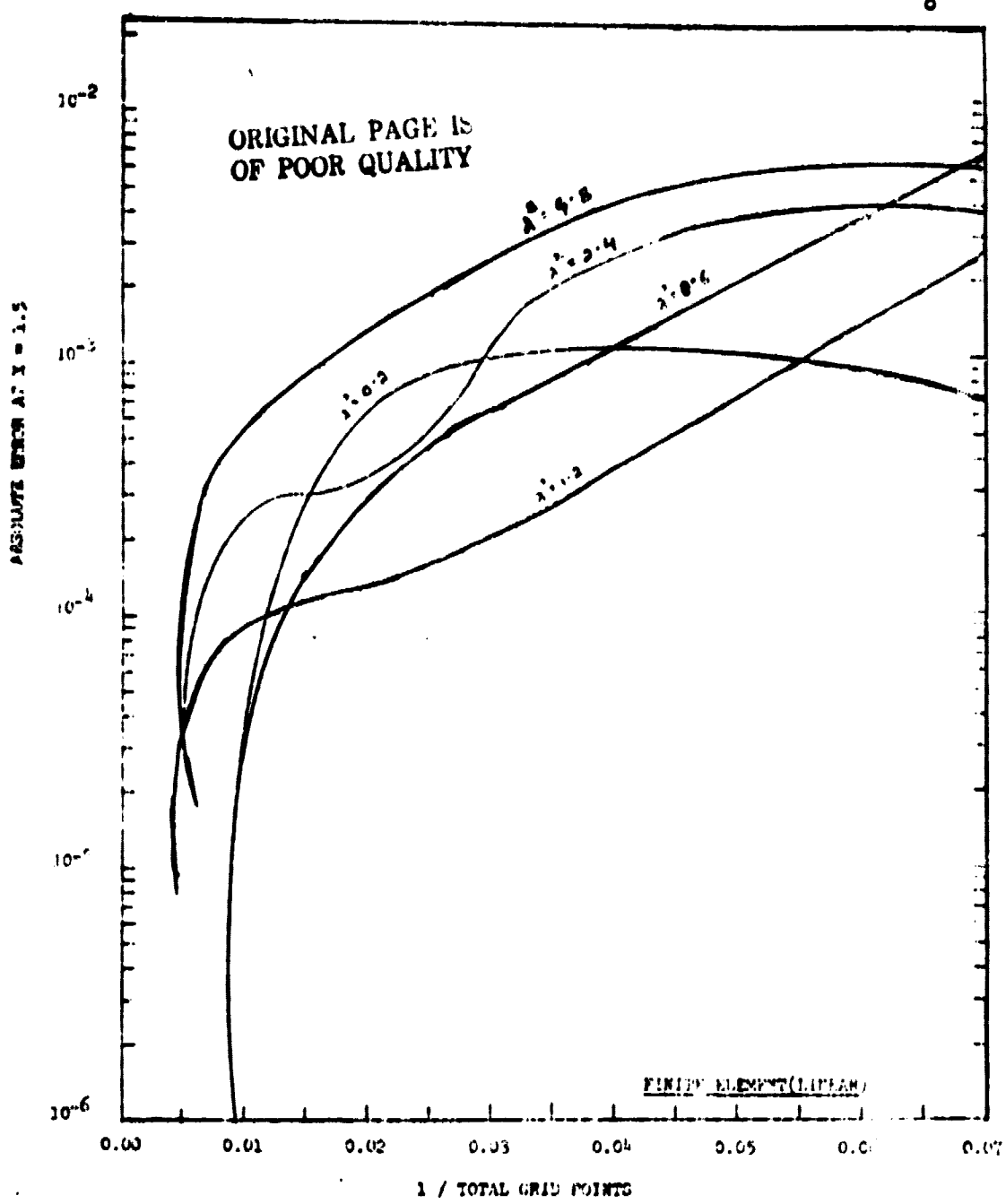


Figure 2.3 Error for finite-bilinear element vs. reciprocal of total number of grid points.

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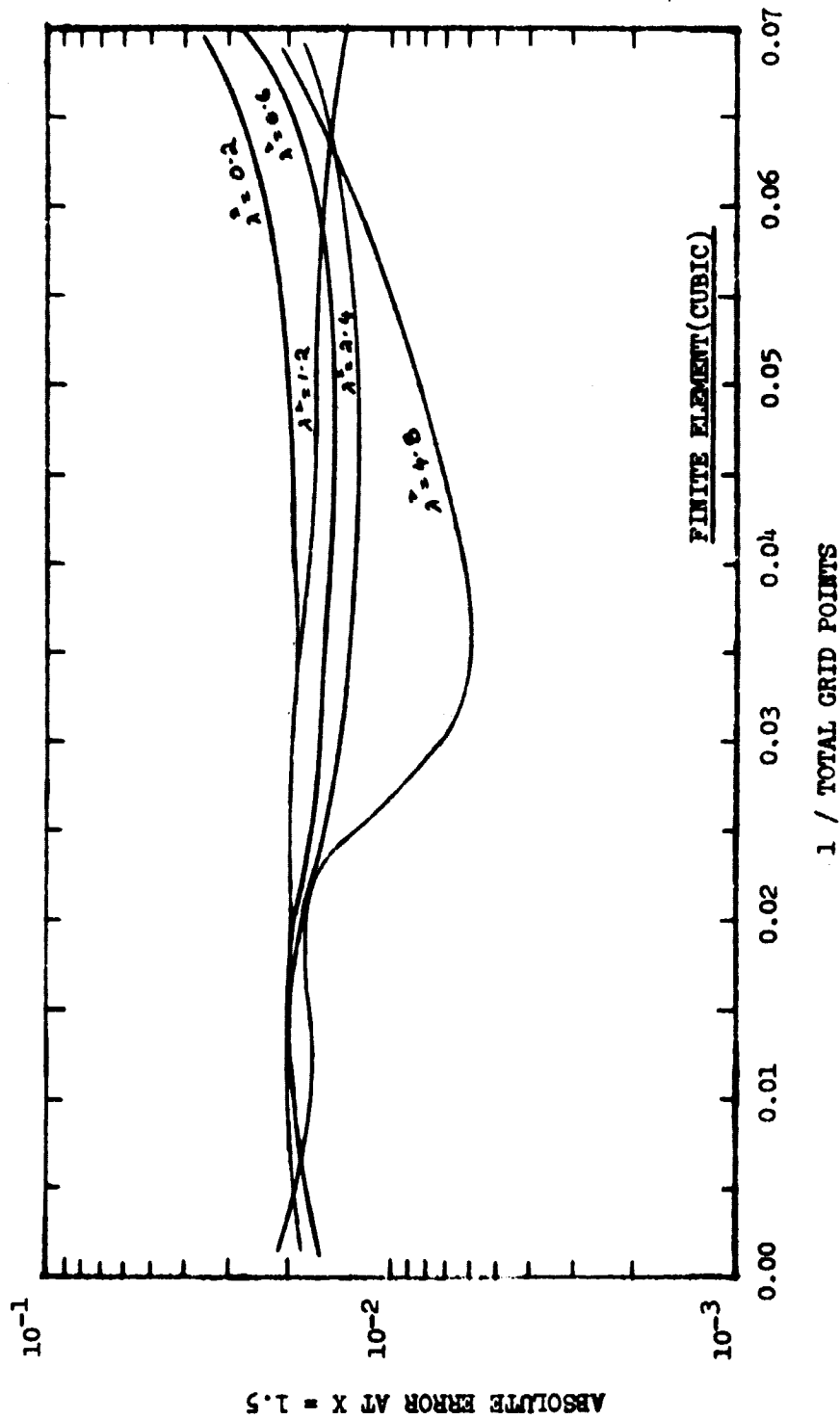


Figure 2.4 Error for finite-bicubic-element vs. reciprocal of total number of grid points.

This experience resulted in some skepticism that the finite element method would be effective for semiconductor problems. A more recent paper has reinforced this attitude.³ This paper indicates that the proper formulations of the semiconductor problem for the finite element approach remain to be demonstrated, and, in agreement with our observations, point out that the application of Galerkin's method is subject to skepticism. Therefore, it was concluded that the further work should be based upon the finite-difference method which we have used before although the finite-element method is intriguing and may be further developed in the future.

The second phase of this program is underway to develop a computational program with which to generate data from a model. During the past quarter, the major emphasis was upon deriving a simple two-dimensional algorithm which could be economically used in a simulation program during its development. It is plausible that this algorithm can be later modified to become adequate for modeling of other effects which are significant in certain situations, e.g., short channel effects, avalanche breakdown, etc.

During the past quarter an algorithm has been developed based upon the usual assumption that the mobile carriers are included in an infinitesimally thick layer of charge at the Si-SiO₂ interface. The current flow is then described by a one-dimensional equation:

$$i = \frac{kT}{q} \mu_N \left(\frac{\partial \mu_L S}{\partial X} + \frac{q \mu_L E_S S}{kT} \right), \quad 0 \leq x \leq a \quad (2.6)$$

where i and S are channel current and charge per unit channel width, E_S is the tangential interface field and μ_N and μ_L are the mobility factors accounting respectively for gate modulation and hot electron effects. This equation is solved iteratively with Poisson's equation which includes two-

dimensional effects:

$$\nabla^2 \psi = -\rho/\epsilon. \quad (2.7)$$

Equation (2.7) will be solved for one segment of a periodic structure with respect to x and equation (2.6) will be integrated to produce auxiliary equations for the boundary conditions at the Si-SiO₂ interface. It will be assumed initially that $S = 0$ at $x = a$, the point at which the normal component of the interface field changes sign. The solution algorithm then proceeds in an iterative fashion to solve (2.6) and (2.7) simultaneously for the potential distribution from which the current, i , is ultimately calculated as a function of the gate, drain and body voltage.

The model at this point admittedly has some short-comings, mainly due to the neglect of generation-recombination mechanisms. Therefore, it will not treat impact avalanche and bulk generated leakage currents. It is believed at this time that such effects can be treated by adding another iterative loop to the algorithm. The major emphasis at this point will be the development of a program for input and output data management and including subroutines which generate data internally within the program and solve systems of equations which will be encountered in implementing the algorithm.

3. REDISTRIBUTION DIFFUSIONS FOR ION-IMPLANTED PREDEPOSITS OF BORON AND PHOSPHORUS IN SOS FILMS.

The objective of this work was to produce curves describing the variation with diffusion time and temperature of the junction depth, sheet resistance and integrated impurity dose. This data has been generated for boron and phosphorus redistributed in nitrogen, dry oxygen and steam ambients for <111> oriented SOS films. The following section presents discussions of the implantation and redistribution model, further program develop, the computational procedure and of the computed results.

3.1 The Redistribution Model:

There are three aspects of the redistribution model which are considered:

(a) the implanted profile, (b) the oxidation model, and (c) the diffusivity model.

(a) The Implanted profile.

The implanted profile is described by the gaussian function,

$$C(y) = C_{\max} \exp \left\{ -\frac{1}{2} \left(\frac{y - R_p}{\Delta R_p} \right)^2 \right\}, \quad (3.1)$$

where C is the concentration, y is the distance from the entrant silicon surface, R_p is the range and ΔR_p is the straggle for the implant. The peak concentration, C_{\max} , is related to the implant dose, Q_{imp} by:

$$C_{\max} = Q_{\text{imp}} / \sqrt{2\pi} \Delta R_p. \quad (3.2)$$

Redistribution data has been generated for the following conditions:⁴

Q_{imp} :	5×10^{12} , 10^{13} , 5×10^{13} , 10^{14}	cm^{-2}
R_p :	0.2735 μm 0.1727 "	80 keV boron implant. 150 keV phosphorus.
ΔR_p :	0.0665 μm 0.0440 "	80 keV boron implant. 150 keV phosphorus.

The doses are light to moderate resulting in concentrations no heavier than $6 \times 10^{18} \text{ cm}^{-3}$, and the range-straggle values are typical of those employed at MSFC. It is assumed that all of the ions become activated shortly after redistribution begins and thereby diffuse by a substitutional mechanism involving vacancies.

(b) Oxidation model:

The oxidation model is assumed to be the same as for bulk silicon and the data of Deal et. al.⁵ has been used to calculate the oxidation rate according to:

$$\frac{dx_0}{dt} = B / (2x_0 + B/C), \quad (3.3)$$

where B and C follow Boltzmann-like temperature dependences. Figures (3.1) and (3.2) illustrate the oxide thickness dependence upon time and temperature for both dry O_2 and steam ambients.

During the oxidation, the silicon film thickness is reduced according to:

$$W = W_0 - \alpha x_0, \quad (3.4)$$

where W_0 is the initial film thickness, taken to be $1 \mu\text{m}$, and $\alpha = 0.45$ is the ratio of the densities of SiO_2 to silicon. Redistribution data is given for $W_0 = 1 \mu\text{m}$ and an initial oxide thickness of $x_0 = 300 \text{ \AA}$.

(c) Diffusivity model:

The diffusivity model for boron was discussed in an earlier report⁶ and it includes a linear dependence of the diffusivity upon the vacancy concentration as well as the field-enhancement effect. The diffusivity model for phosphorus includes only the field-enhancement effect which is sufficient to describe the non-linear behavior of phosphorus diffusions at concentrations lower than 10^{19} cm^{-3} as shown by Barry⁷ and Fair and Tsai⁸. The diffusivity-

temperature dependence is after Fair⁹ and Fair and Tsai⁸ adaptation of data by Ghostagore¹⁰. For either boron or phosphorous the effective diffusivity is given by:

$$D_{\text{eff}} = D(u) \times (1 + u / \sqrt{u^2 + 1}) , \quad (3.4)$$

where,

$$u = C / 2 n_i , \quad (3.5)$$

and,

$$\begin{aligned} D(u) &= D_B^* u, \quad \text{for boron,} \\ &= D_P^* , \quad \text{for phosphorus.} \end{aligned} \quad (3.6)$$

and where n_i is the intrinsic carrier concentration at the diffusion temperature and D_B^* and D_P^* are the intrinsic diffusivities of boron and phosphorus:

$$\begin{aligned} D_B^* &= 3.17 \exp (-3.59\text{eV} / k_B T) \text{ cm}^2/\text{sec.} , \\ D_P^* &= 3.85 \exp (-3.66\text{eV} / k_B T) \end{aligned} \quad (3.7)$$

3.2 Further Program Development:

The program which was used to generate the data has been described in detail in an earlier report. It was noted that the program was developed in such a way that one could take advantage of a normalization procedure for predeposition diffusions and generate data applicable to different film thicknesses. However, it is not possible to gain such an advantage for re-distribution diffusions involving ion-implants or growth of an oxide. Then the program was used to generate data, it was discovered that some other features of the program are extraneous unless further refined.

The program was developed to account for both thin and thick oxides such as would be encountered in some practical situations. However, such a simulation requires the incorporation of a warped grid system, a modification which would require considerably more effort. Therefore, the variable oxide feature

is of limited value at this time, since the program, at best, only approximates the conditions for growth of a very thin oxide during redistribution.

A modification was made which allows accurate treatment of redistribution under oxidizing conditions when only a single oxide thickness is involved. The original program treated the oxidation process with regard to the boundary conditions; however, unlike the case of bulk silicon, one must also account for the reduction of the silicon film thickness. This feature is now included in the program. During the simulation of a redistribution in an oxidizing ambient, the vertical grid spacing continuously shrinks while the horizontal grid spacing is constant. The modification does not show up on logic flow diagrams at the level of detail which has previously been given. For completeness, a new listing of the affected main and sub-programs is given in the appendix.

3.3 Computational Procedure:

The program described in an earlier report, and modified as described in the preceding, was used to generate the data. Two-dimensional data was obtained in the form of isoconcentration contours for typical situations. The bulk of the data which can be correlated with experimental measurements is generated using a quasi-one-dimensional model in a manner described in a previous report.⁶ A brief review of the procedure is given in the following.

For generation of sheet resistance, junction depth and integrated impurity dose data as a function of time and temperature, only a one-dimensional profile need be calculated. This is accomplished by making the horizontal grid only three units wide but keeping the field six film thicknesses wide. Periodic boundary conditions for the horizontal dimensions are employed in the program and result in a calculation which produces the vertical profile

equivalent to a none-dimensional model. Thus without sacrificing the generality of the program for treating two-dimensional cases, the amount of computing time is drastically reduced when the data that is desired does not require the full power of the program.

The vertical grid varies from thirty one to sixty one points as required for accuracy in details of the profile, and most of the data is not sensitive to the number of grid points used if the number is chosen in this range. For the purpose of illustrating the unusual nature of phosphorous profiles, the larger number of points was required.

3.4 Discussion of Results:

First, some of the unusual behavior of redistribution diffusions in SOS films will be discussed in this section. Next, the format for the calculated curves will be discussed, and, finally, the bulk of the generated data is given in the appendix without further comment.

Figures (3.1) and (3.2) illustrate the oxide thickness growth and silicon film thickness reduction as functions of time for $\langle 111 \rangle$ silicon films oxidized in steam and dry O_2 ambients. The evolution traced beginning with an initial oxide of 300 Å thickness on an SOS film of 1 μm initial thickness. The curves are shown for four temperatures. The data are necessary for interpreting some of the results for simulated redistributions.

Figures (3.3) and (3.4) show impurity profiles for boron and phosphorus implants being redistributed in a steam ambient at 1000 deg. C. The profiles are all plotted with a common origin as would be the case for experimentally derived profiles where the Si-SiO₂ interface would serve as the logical origin. However, the profiles are normalized with respect to the film thickness which

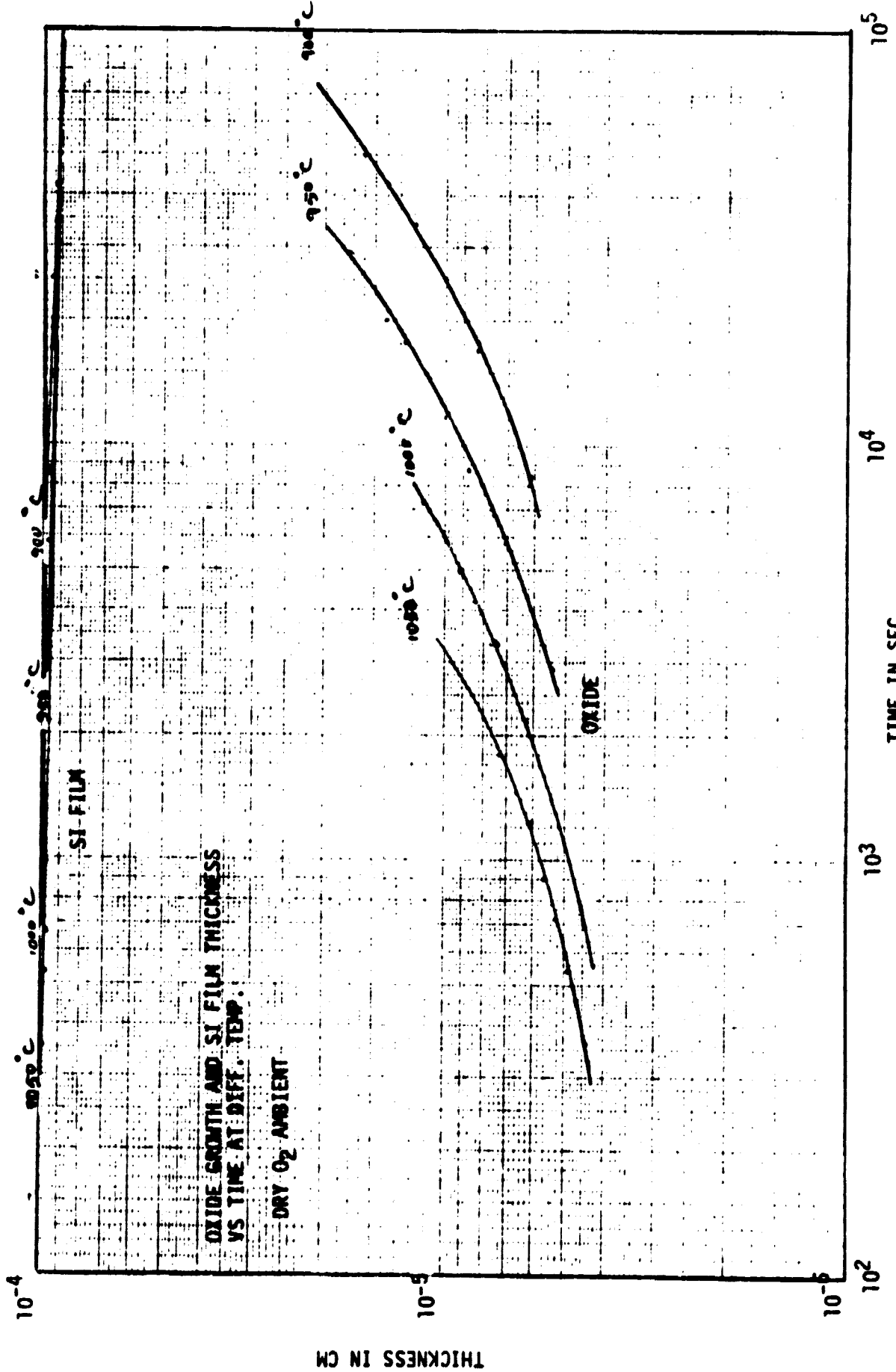


Figure 3.1

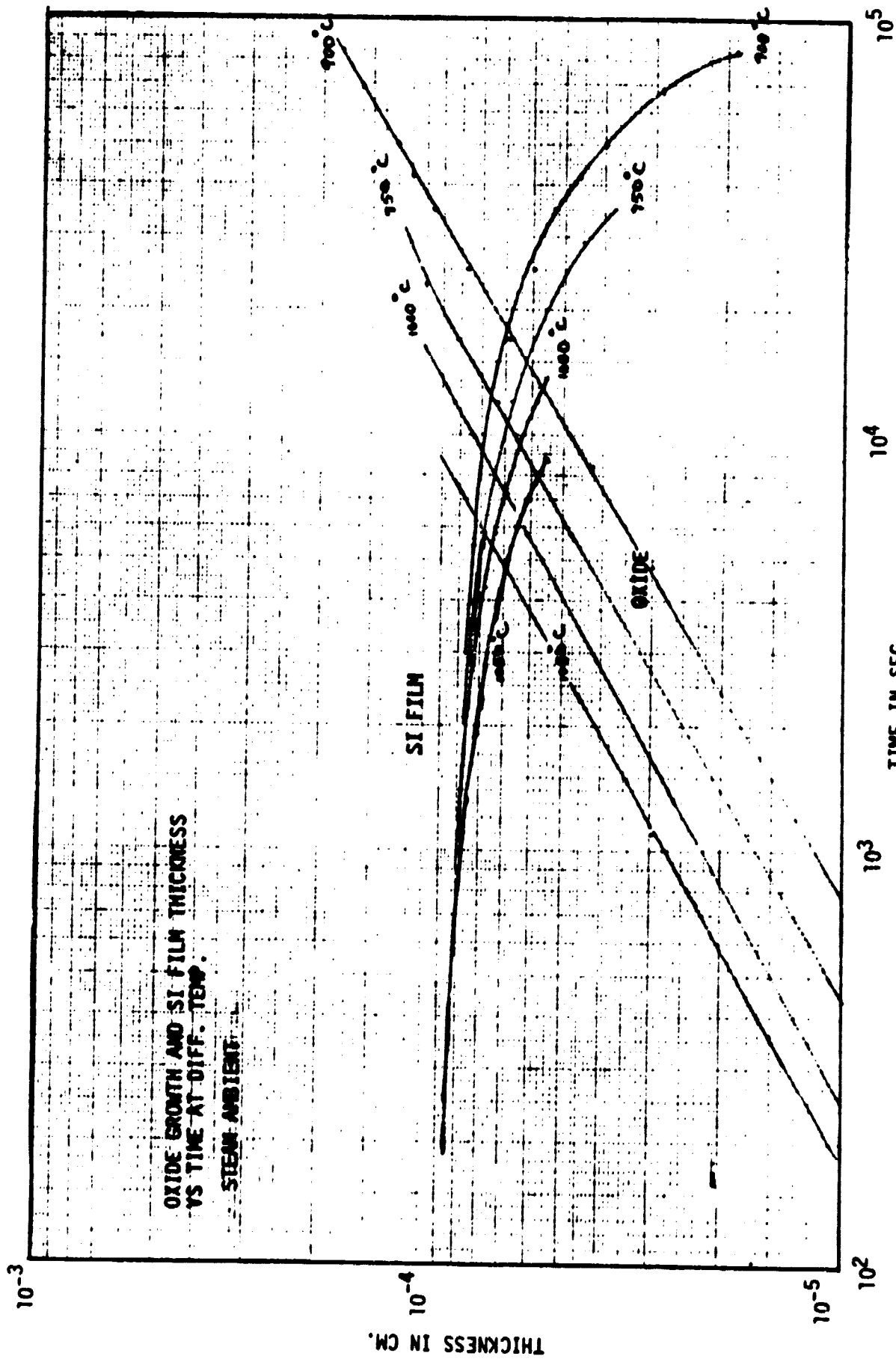
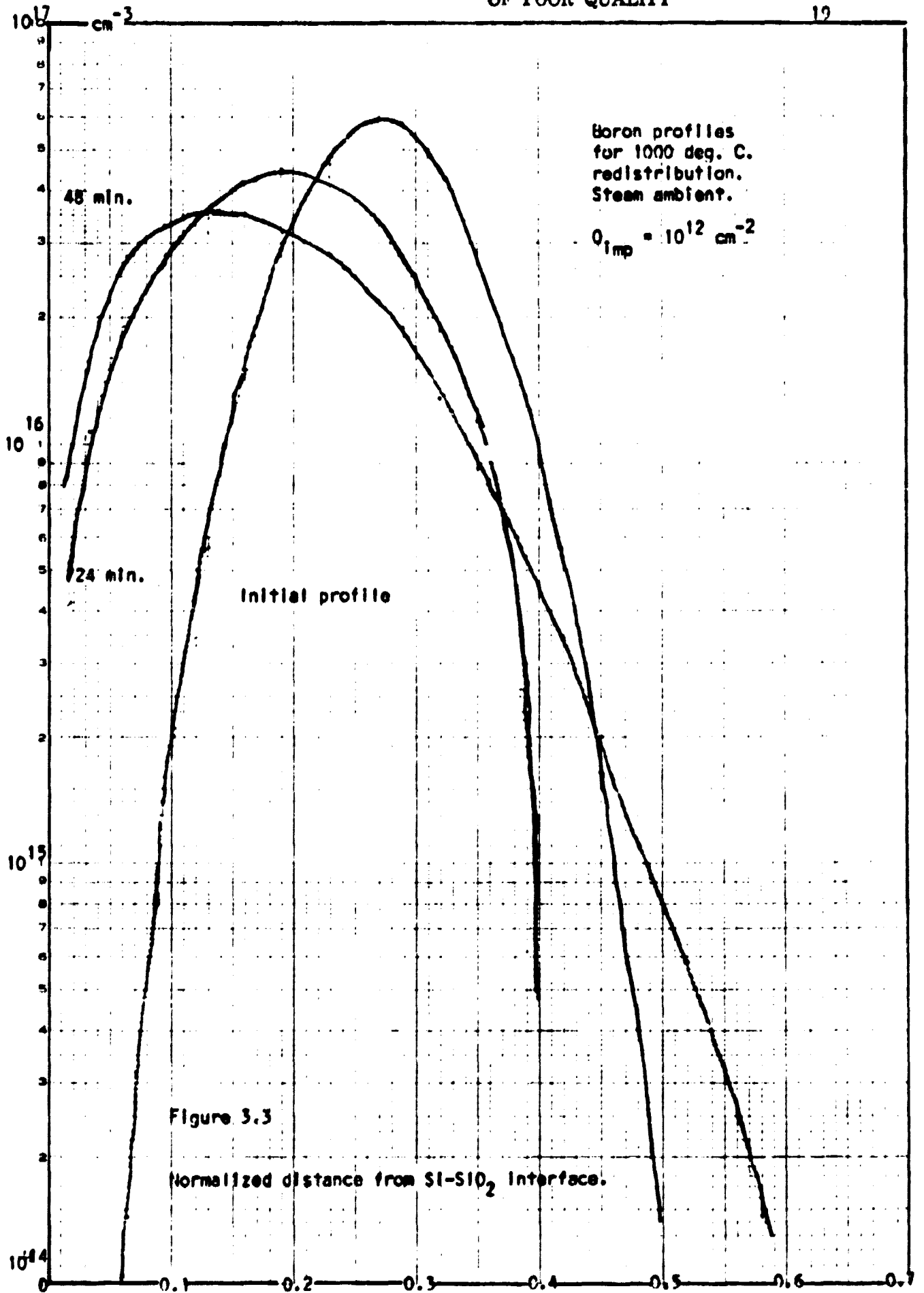


Figure 3.2

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3400 DIETZEN GRAPH PAPER
SEMI-LOGARITHMIC
3 CYCLES X 10 DIVISIONS PER INCH



NO. 340R-LS10 DIETZGEN GRAPH PAPER
SEMI-LOGARITHMIC
5 CYCLES X 10 DIVISIONS PER INCH

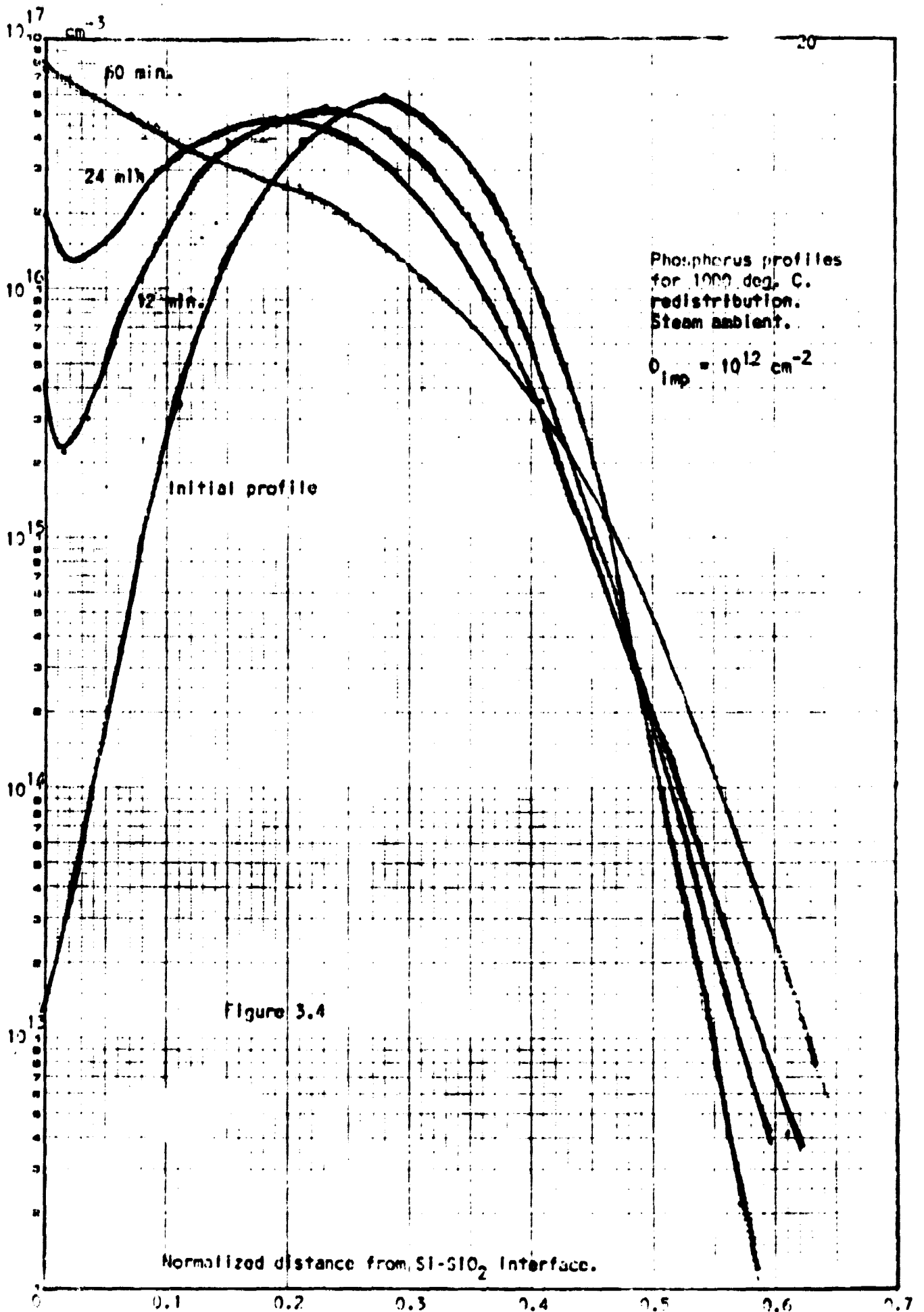


Figure 3.4

Normalized distance from Si-SiO₂ interface.

is of course shrinking. The boron profiles are not unusual but show the well-known leaching effect due to segregation into the oxide. The phosphorus profiles show the effect of impurities being rejected from the oxide. There is a pile-up of impurities in front of the advancing Si-SiO₂ interface and then a dip which eventually disappears. It is easy for one to draw an erroneous conclusion from observing the profiles, because it appears that the integrated dose should increase for at least remain constant and the sheet resistance should decrease with time. This is not true. Although the segregation coefficient favors phosphorus in silicon vs. SiO₂, eventually all of the phosphorus will be in the SiO₂ when the SOS film is completely oxidized since the model assumes that there is no diffusion into the sapphire.

Figures (3.5-3.7) illustrate the behavior of the junction migration, sheet resistance variation, and integrated impurity dose variation over a long period of time. All of the curves are plotted with respect to normalized time, and true time is obtained by multiplying by the normalizing time value given on the plot. Junction depths are in microns, sheet resistance values are in ohms, and dose values are in cm⁻² units unless otherwise marked. The curves are given in the typical format for all of the data.

For an ion-implanted profile, there are in fact two junctions until one of the junctions emerges at the Si-SiO₂ interface. Therefore, the sheet resistance values are for the buried layer until the front junction disappears. This typically occurs in a short time compared with that for through-diffusion of the back junction. Figure (3.5) illustrates the through-diffusion of the back junction for the heavier doses. This always occurs for redistribution in a nitrogen ambient but not necessarily so for an oxidizing ambient. After the through diffusion, or even before for light doses, the junction depth will eventually decrease due to the reduction of the film thickness or due to the

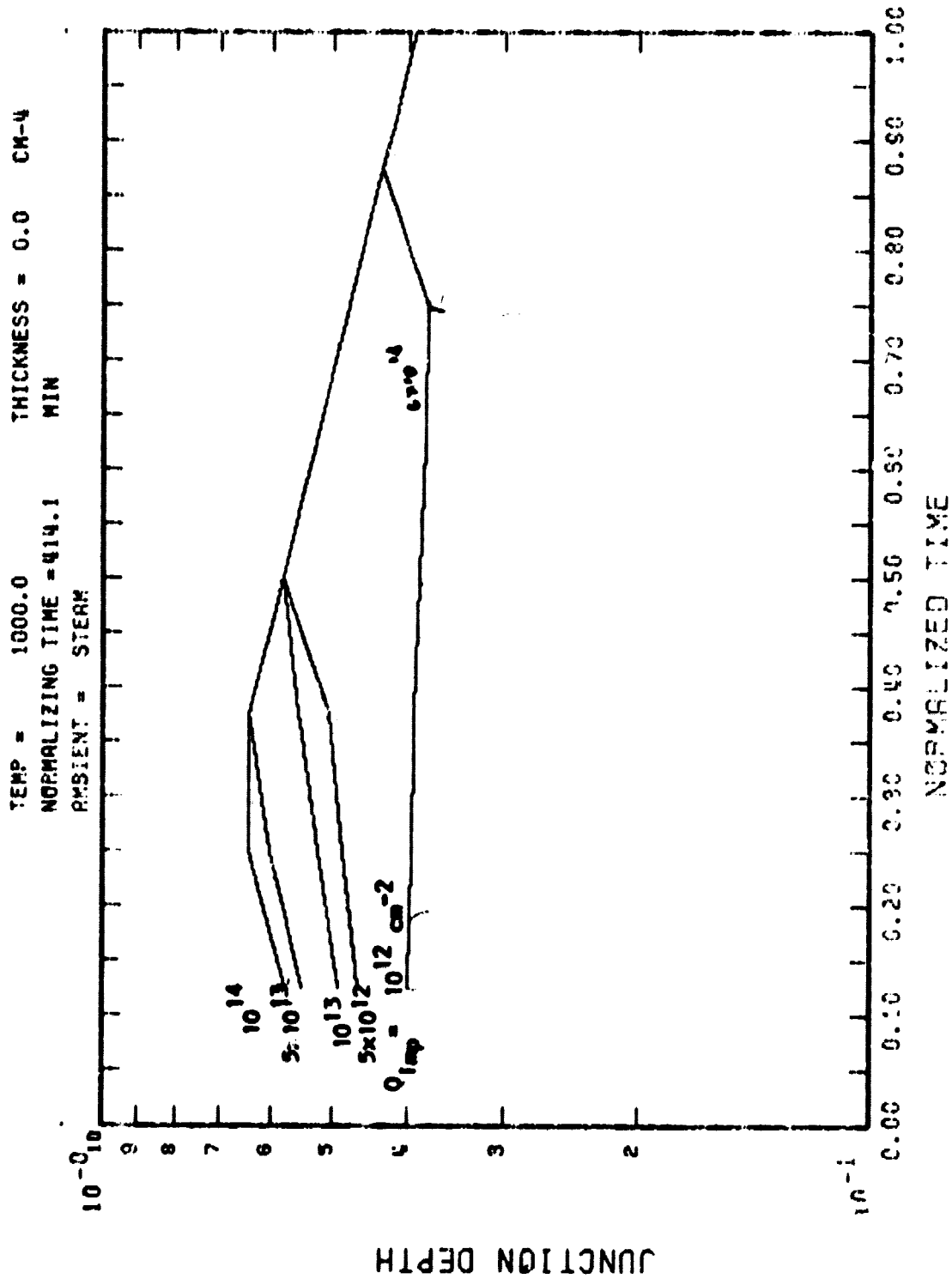


Figure 3.5 Junction position with respect to Si-SiO₂ interface for Boron redistribution.

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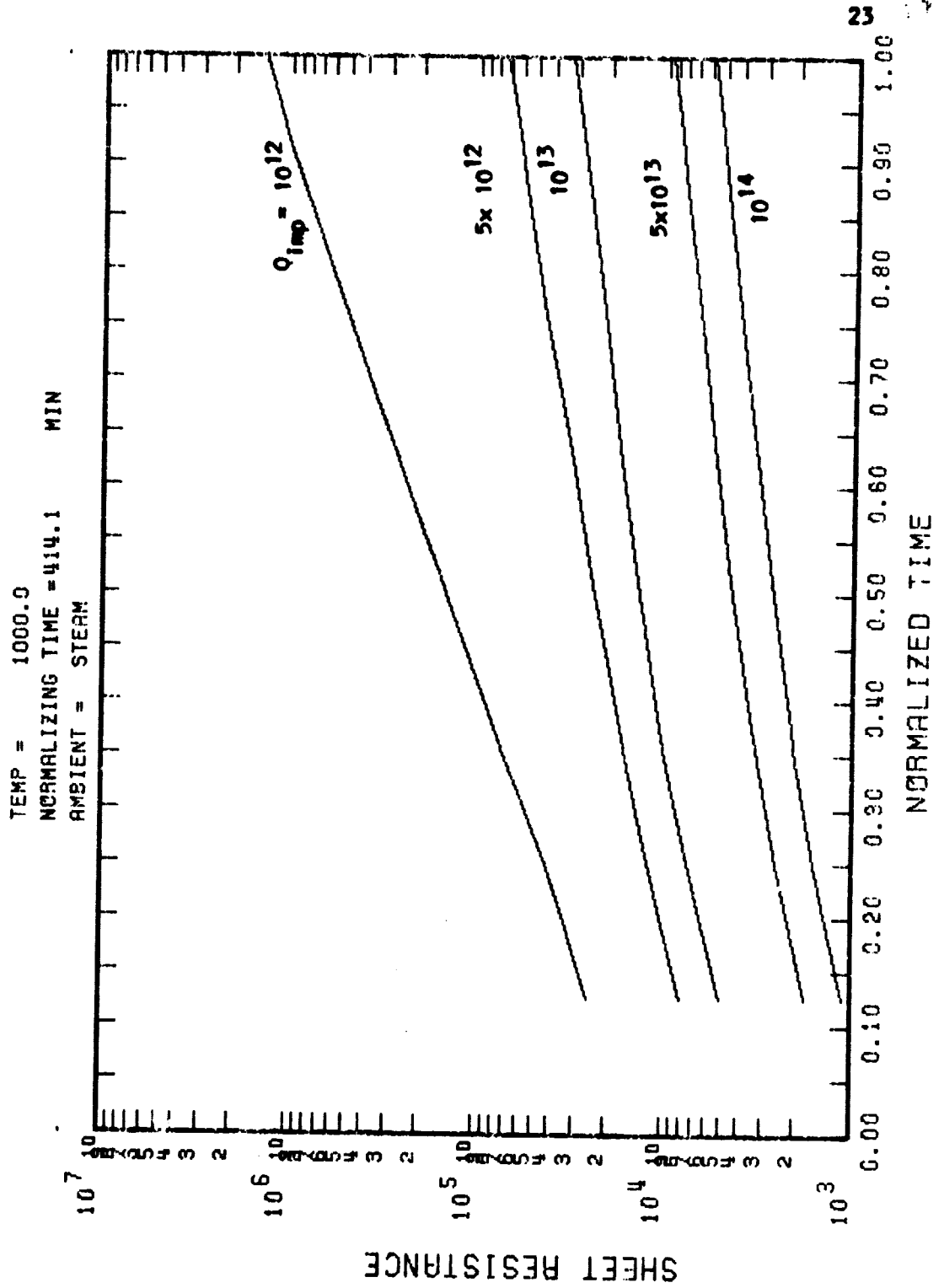


Figure 3.6 Sheet resistance for Boron redistribution.

B

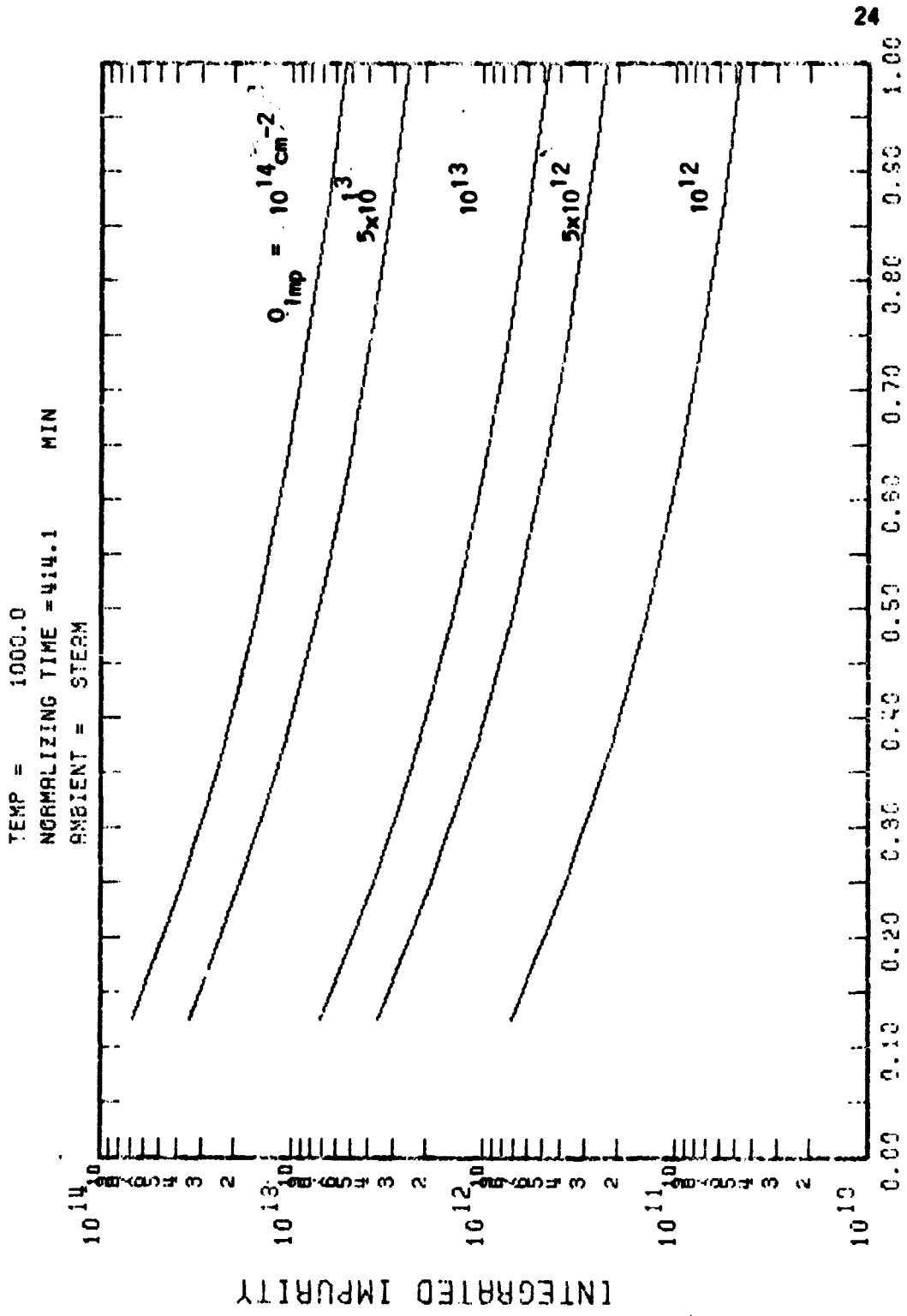


Figure 3.7 Variation of Dose for Boron redistribution.

relatively slow advancement of the junction with respect to the moving Si-SiO₂ interface. In some of the data presented in the appendix, the junction appears to remain almost stationary for this same reason. The variation of the sheet resistance and dose with redistribution time also may appear strange when compared with results for bulk silicon; however, consideration of the previously mentioned factors also explains these results.

Two-dimensional isoconcentration contours are given in the appendix for the various ambients and the two impurity types. The results are not as remarkable as those given in the last report which were for chemically pre-deposited boron. In that case, there was initially a heavy concentration of fast diffusing impurities at the Si-SiO₂ interface which were strongly retarded due to the segregation phenomena. This does not happen with the ion-implanted predeposit because the initial profile lies below the interface at which the segregation phenomena is effective.

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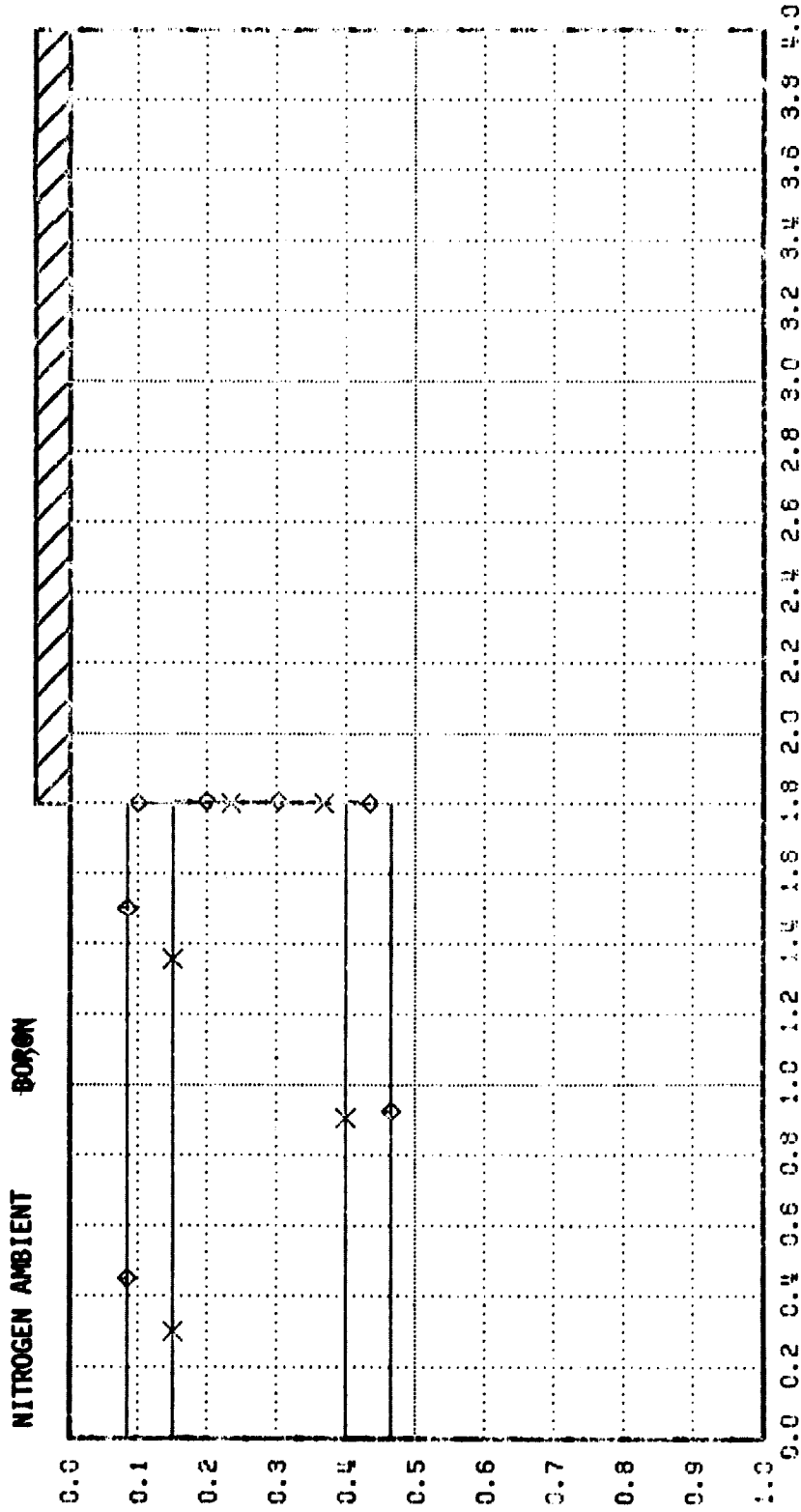
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APPENDIX

BORON DATA

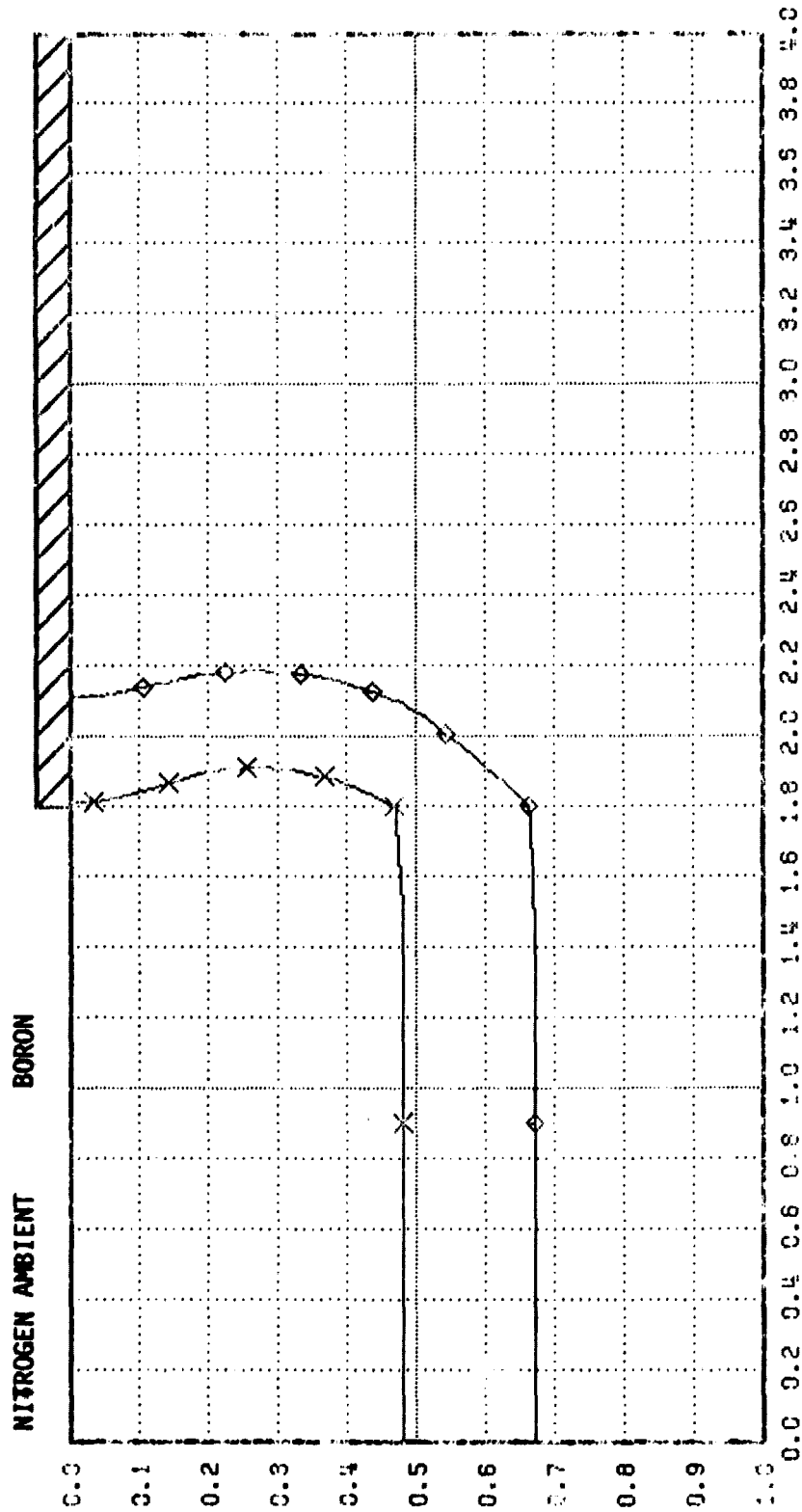
E - 1.0E20
 O - 1.0E19
 A - 1.0E18
 + - 1.0E17
 X - 1.0E16
 D - 1.0E15

χ^2
 TEMPERATURE = 0.0480
 TIME STEP = 1000.
 TIME = 0.00



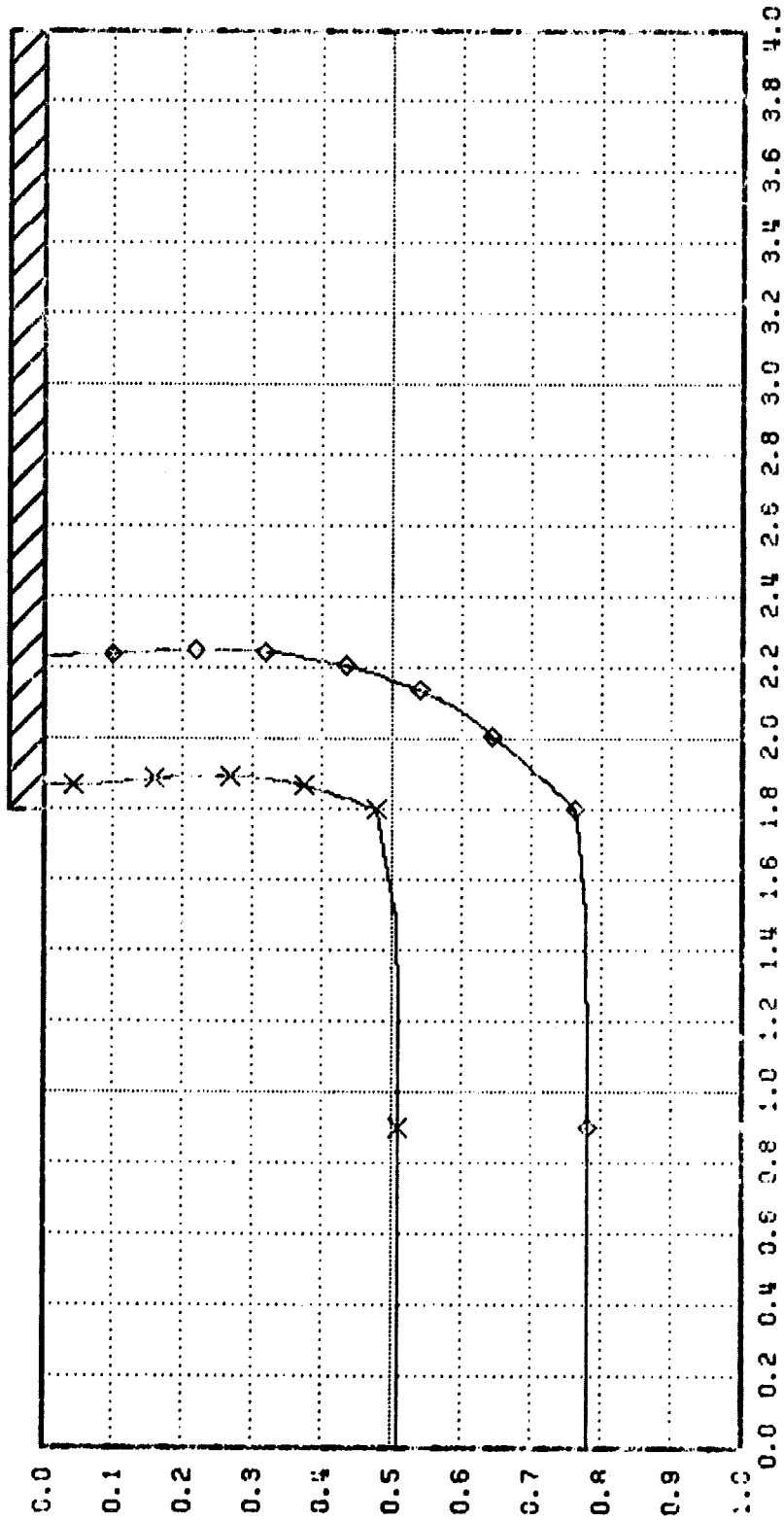
λ^2 = 1.0E20
TEMPERATURE = 0.0480
TIME STEP = 1000.
TIME = 0.20

□ = 1.0E19
△ = 1.0E18
+ = 1.0E17
x = 1.0E16
◇ = 1.0E15



χ^2 = 1.0E20
 TEMPERATURE = 0.0480
 TIME STEP = 1000.
 TIME = 20
 TIME = 0.40

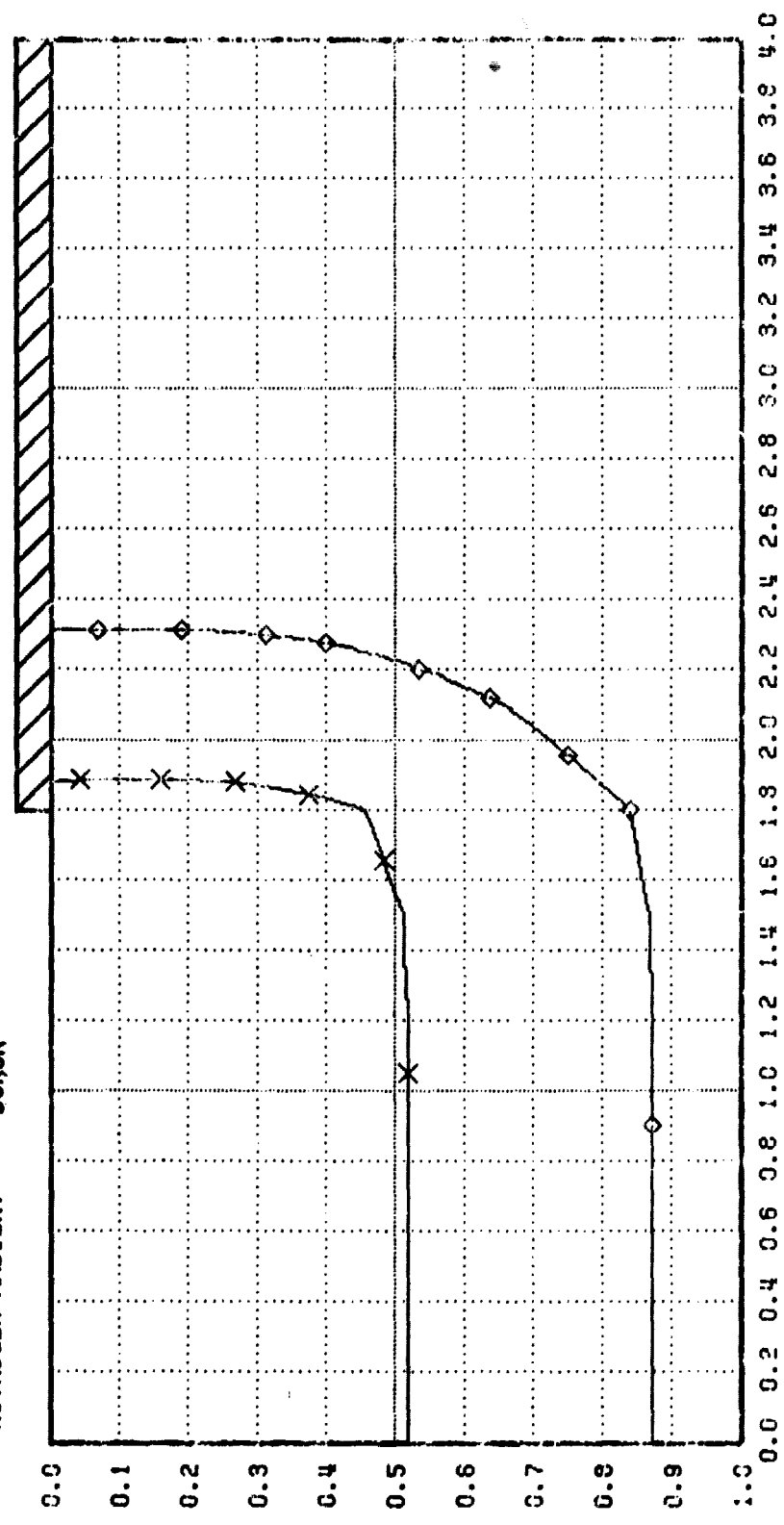
NITROGEN AMBIENT BORON



λ^2 TEMPERATURE = 0.0480
 TIME STEP = 1000.
 TIME = 30
 TIME = 0.60

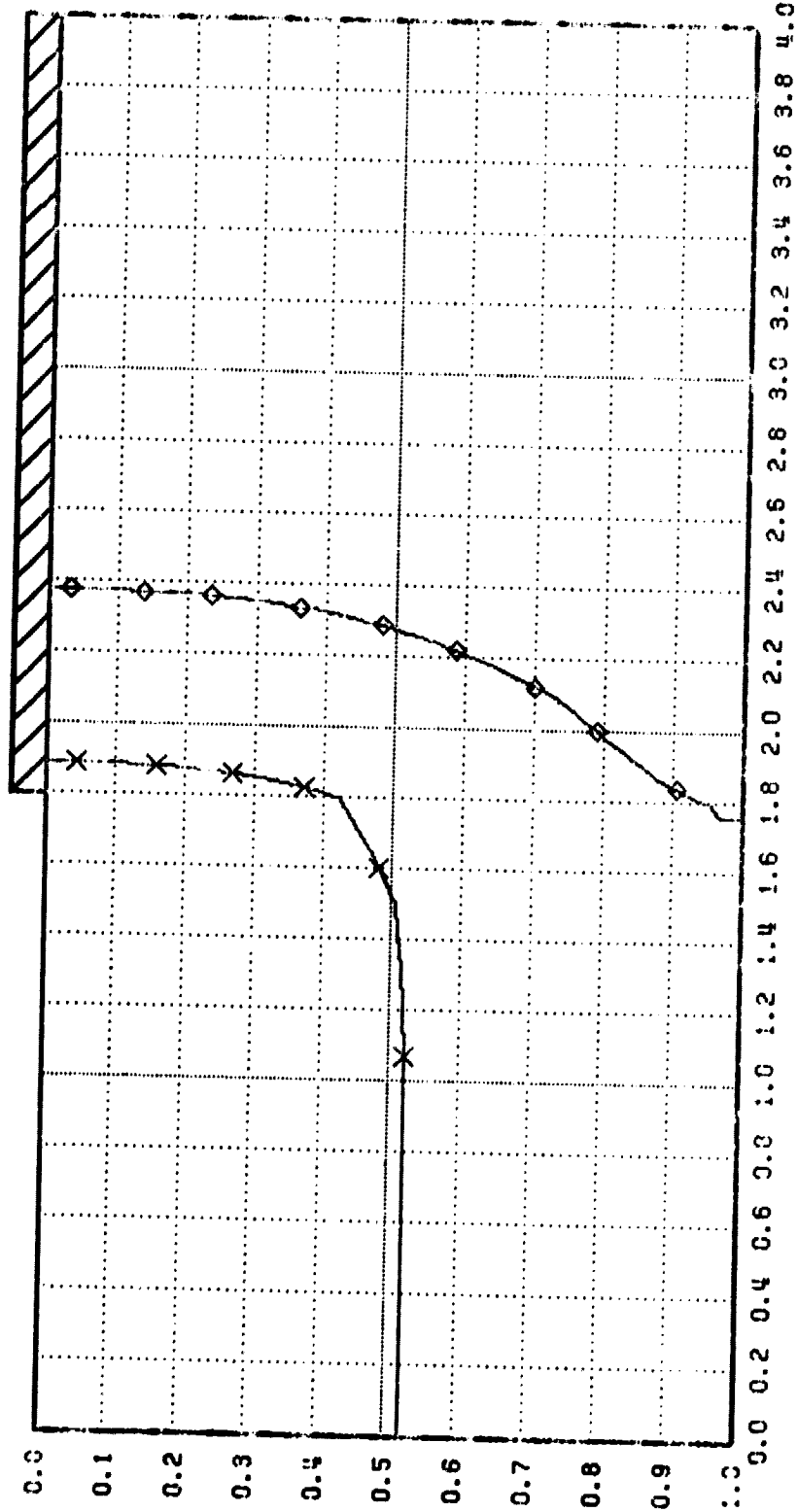
□ - 1.0E20
 ○ - 1.0E16
 △ - 1.0E18
 + - 1.0E17
 × - 1.0E18
 ◇ - 1.0E15

NITROGEN AMBIENT BORGON



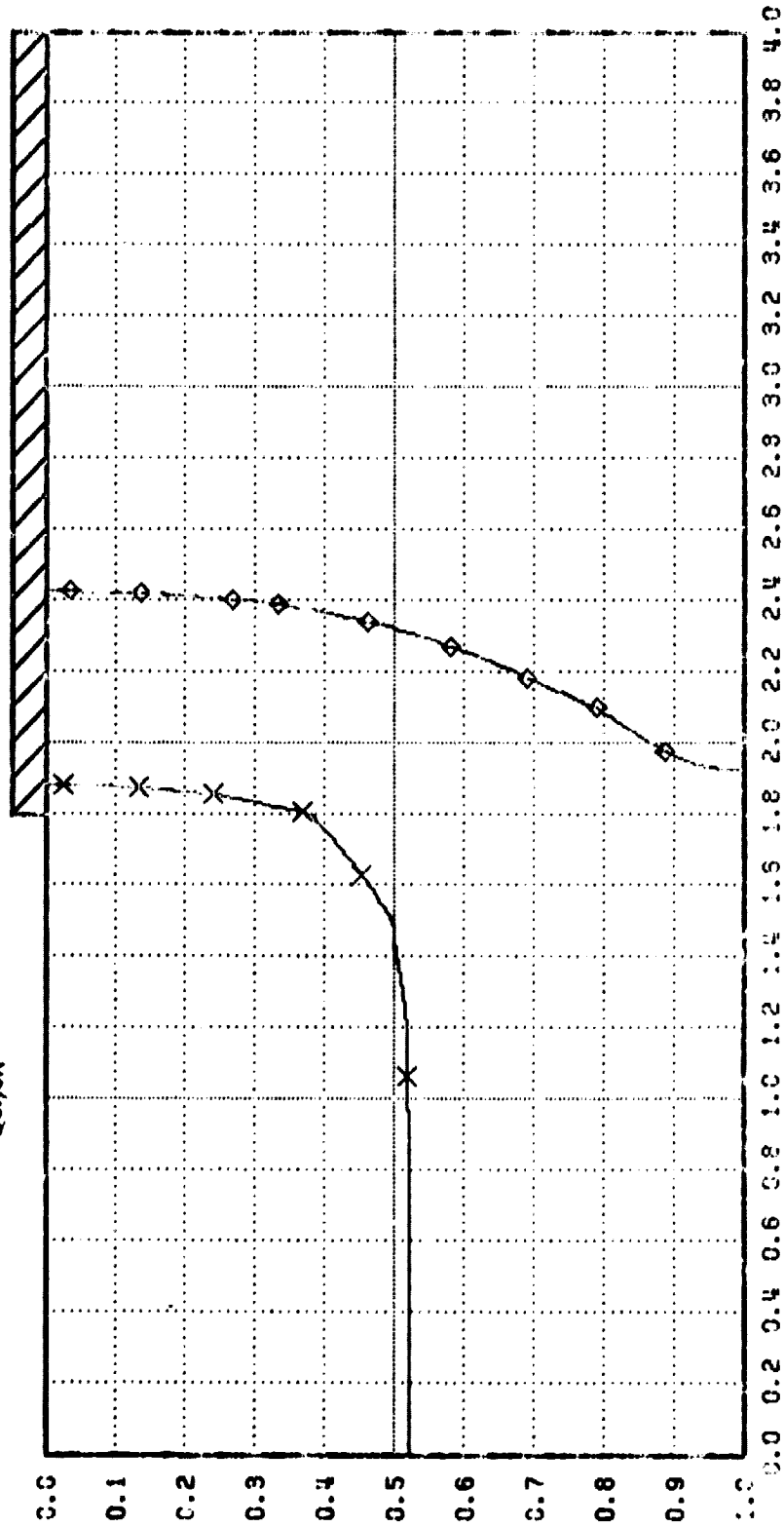
$\lambda^2 = 1.0E20$
 $\square = 1.0E19$
 $\circ = 1.0E18$
 $\triangle = 1.0E17$
 $+ = 1.0E16$
 $\times = 1.0E15$
 $\diamond = 1.0E14$

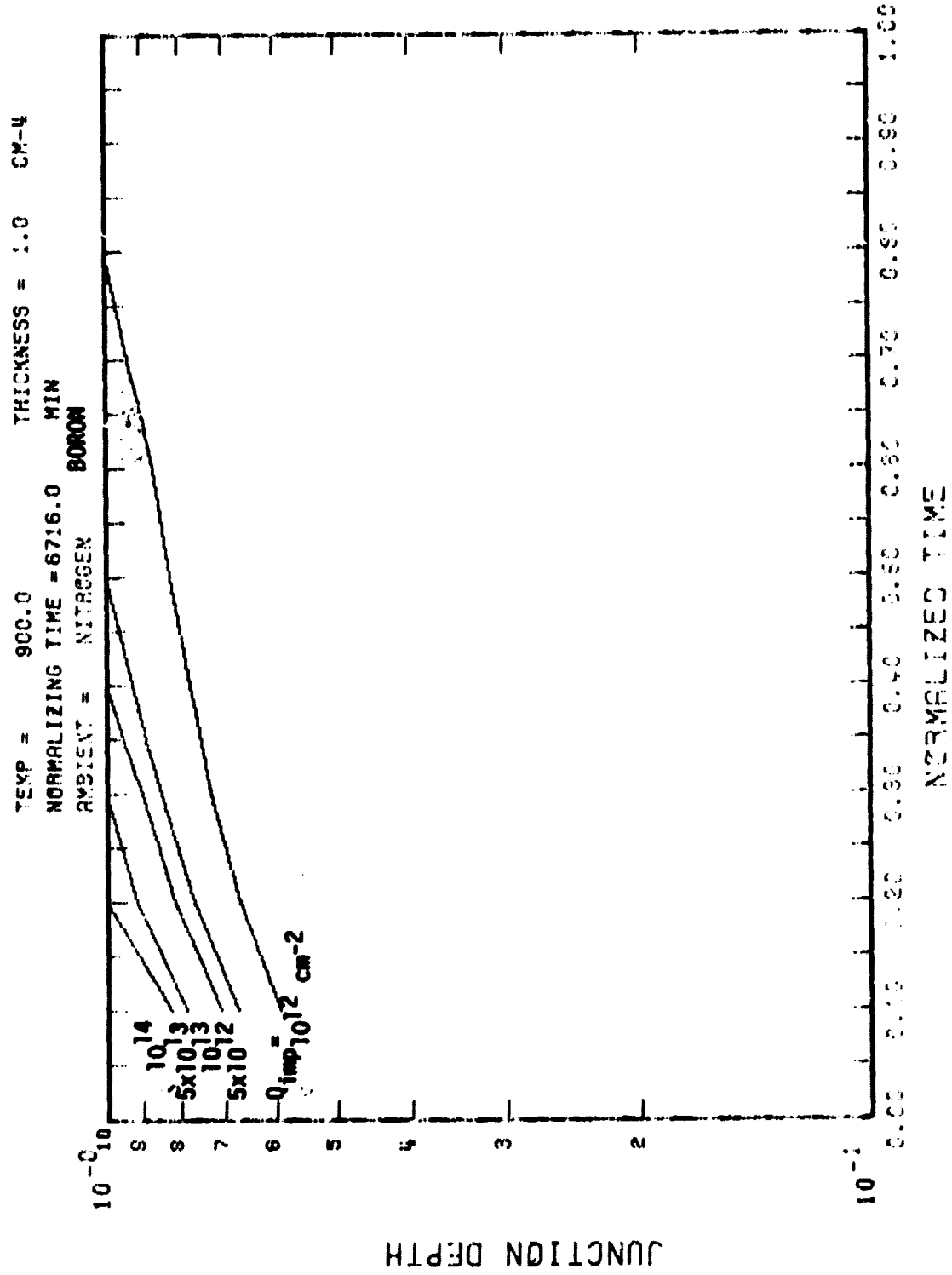
$\lambda^2 = 0.0480$
 TEMPERATURE = 1000.
 TIME STEP = 40
 TIME = 0.80
 NITROGEN AMBIENT BORON

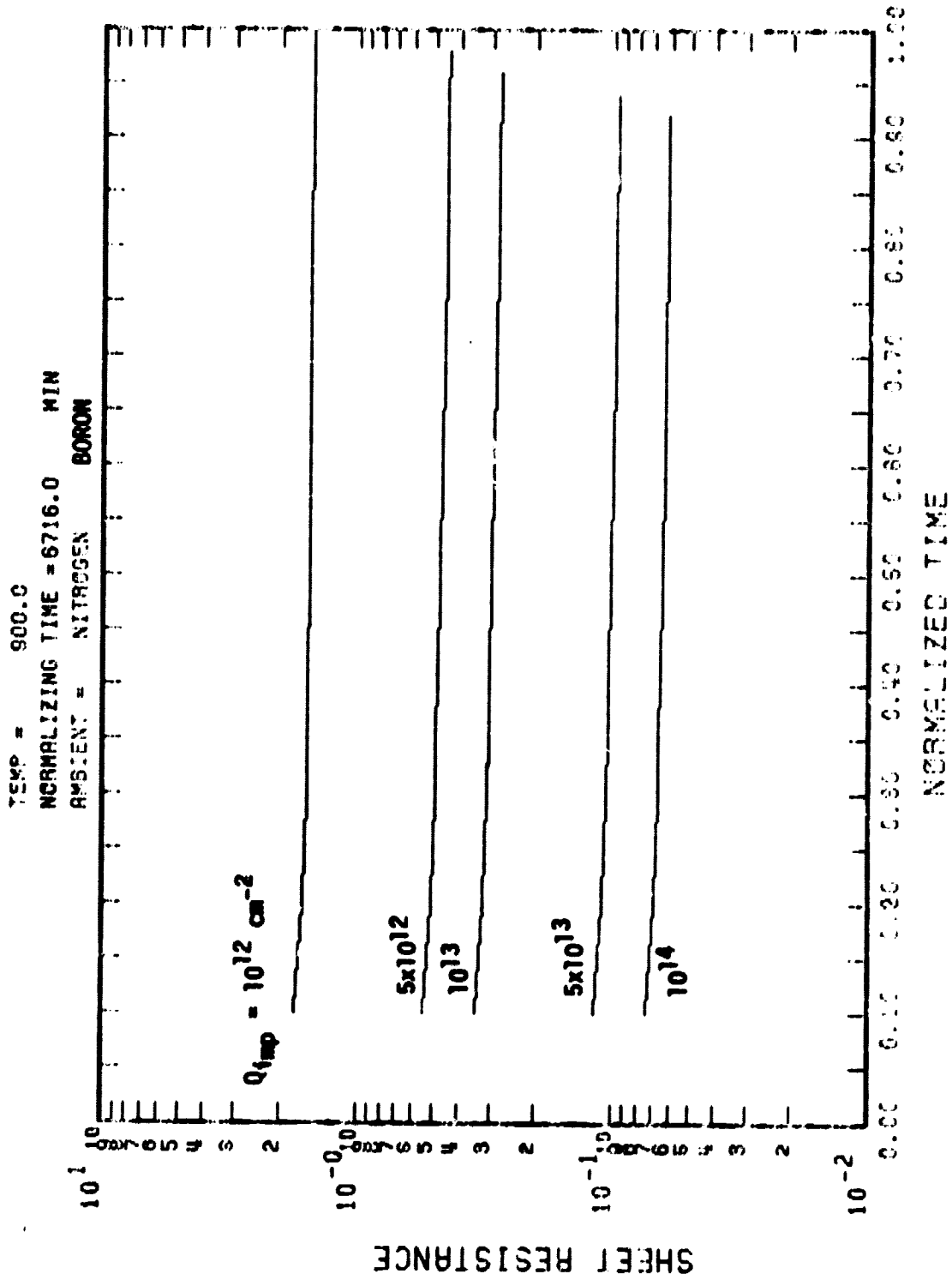


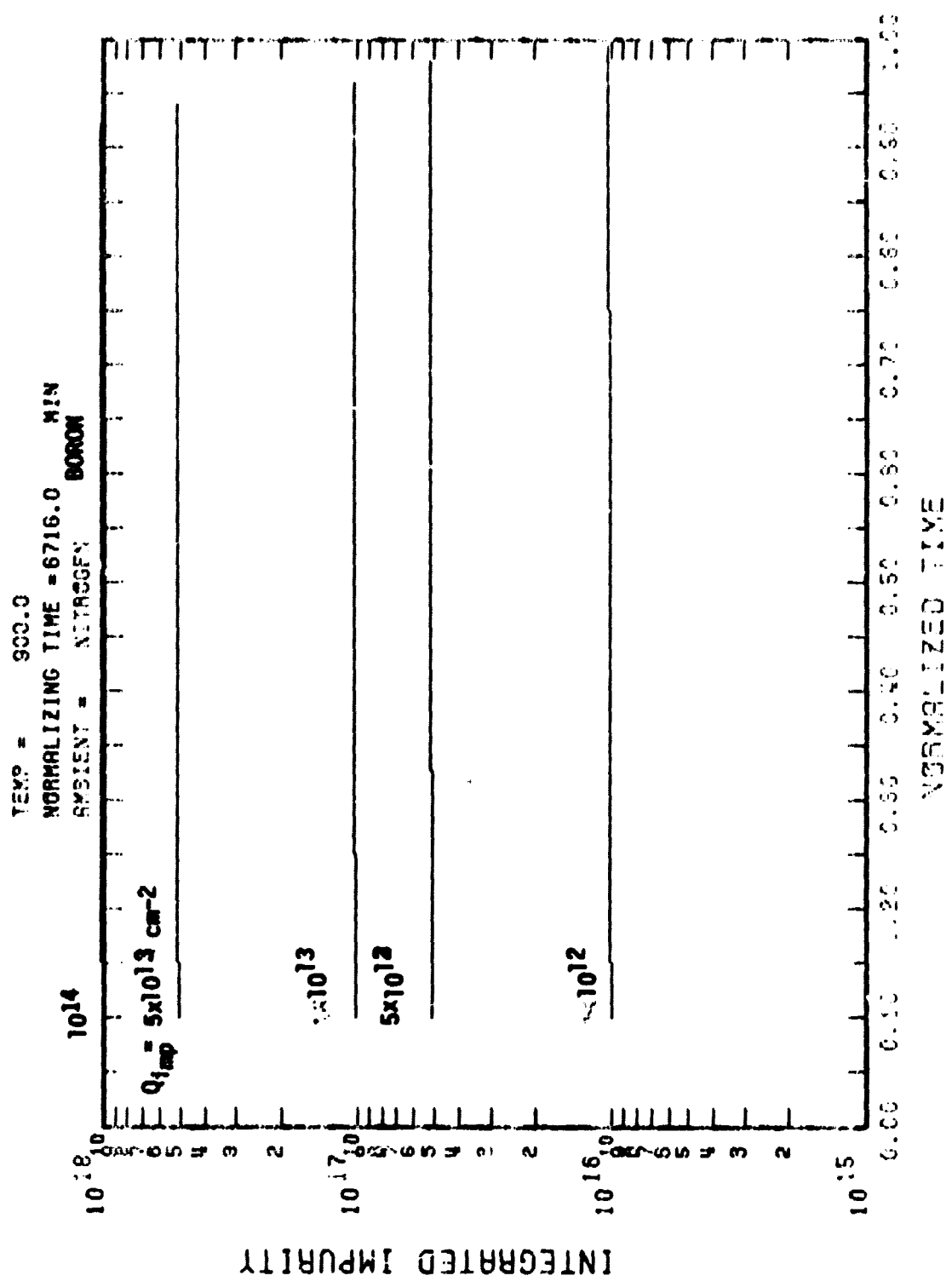
λ^2
 TEMPERATURE = 0.0480
 TIME STEP = 1000.
 TIME = 50
 TIME = 1.00

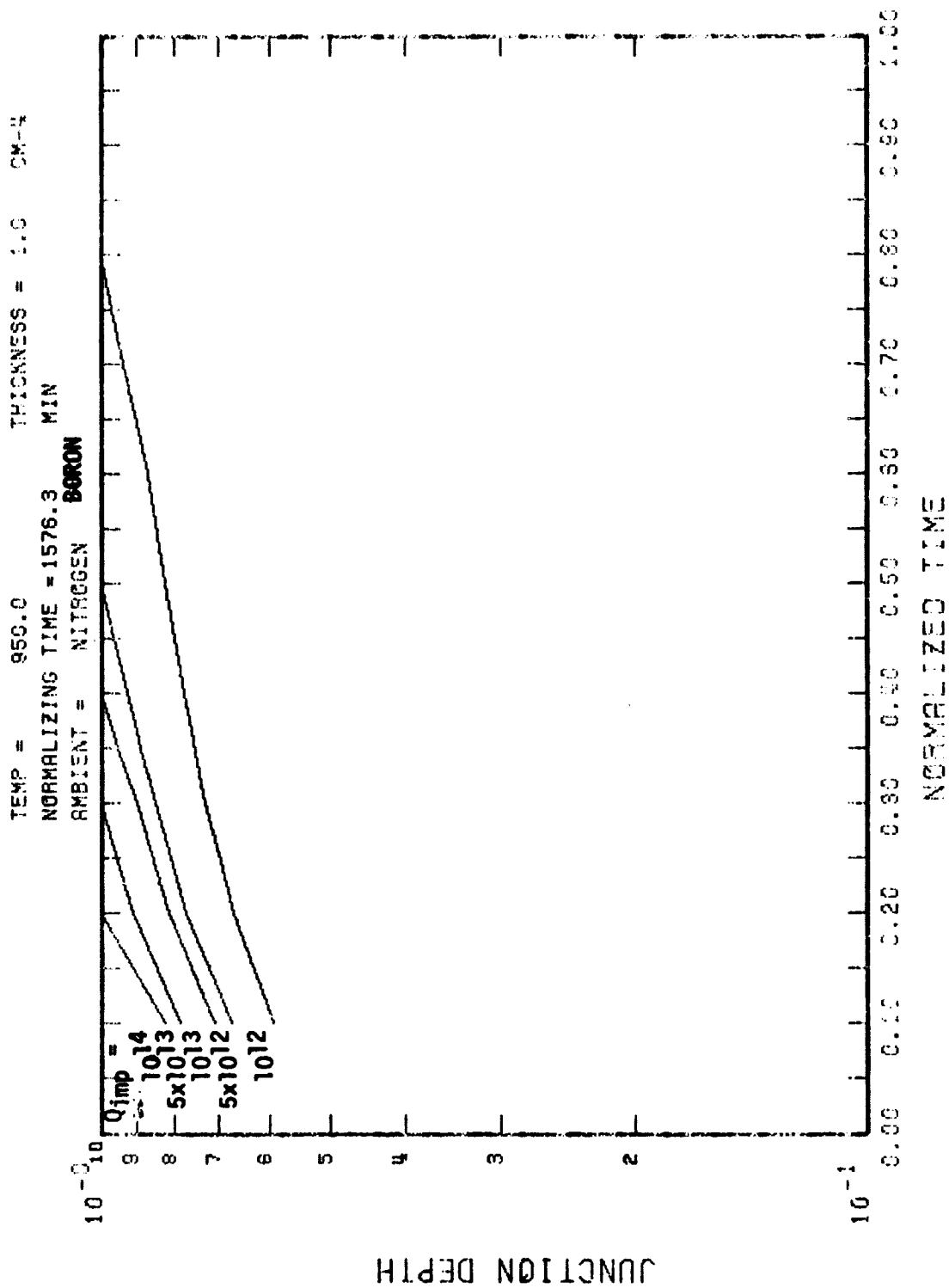
NITROGEN AMBIENT BORGON

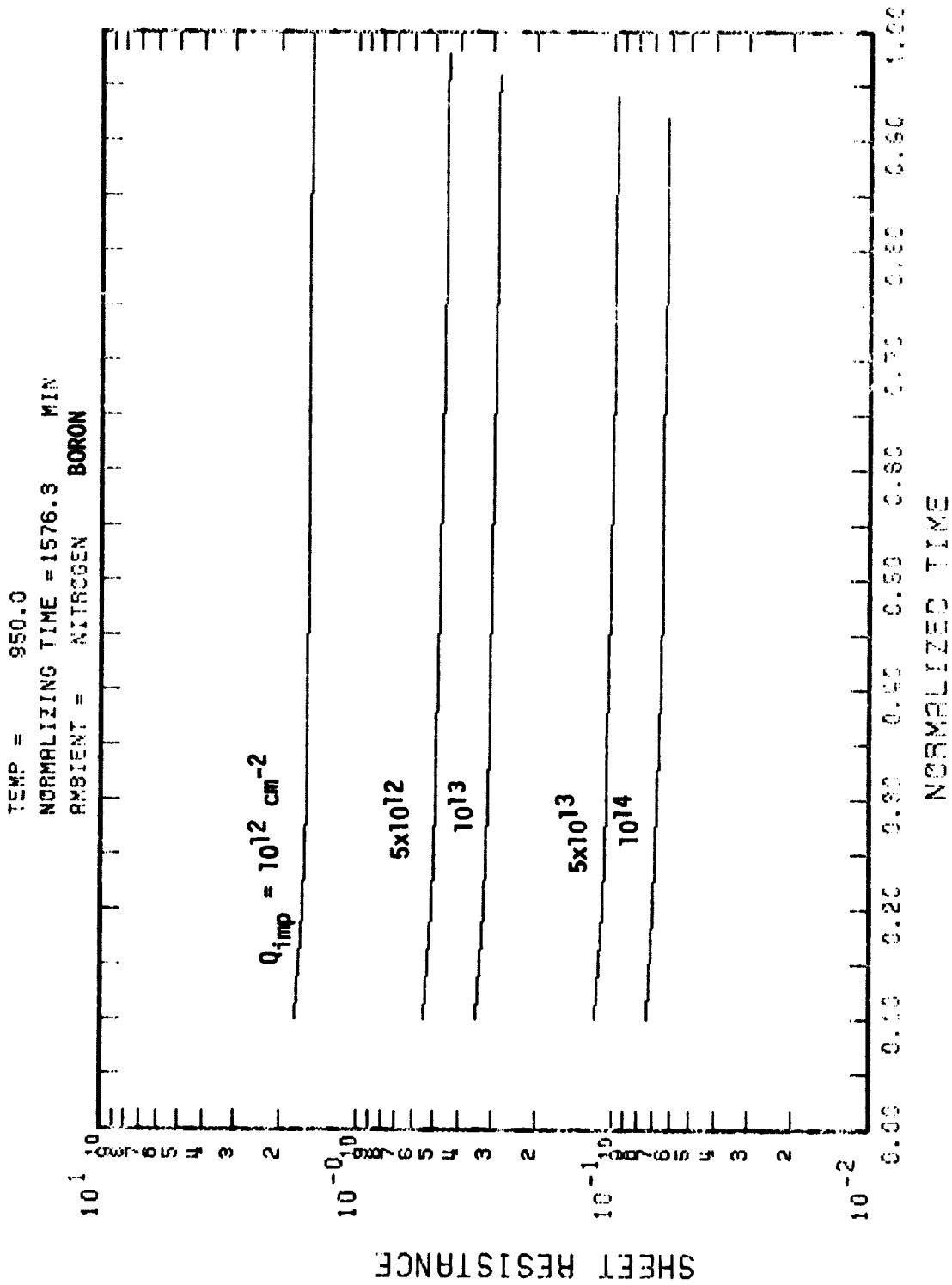


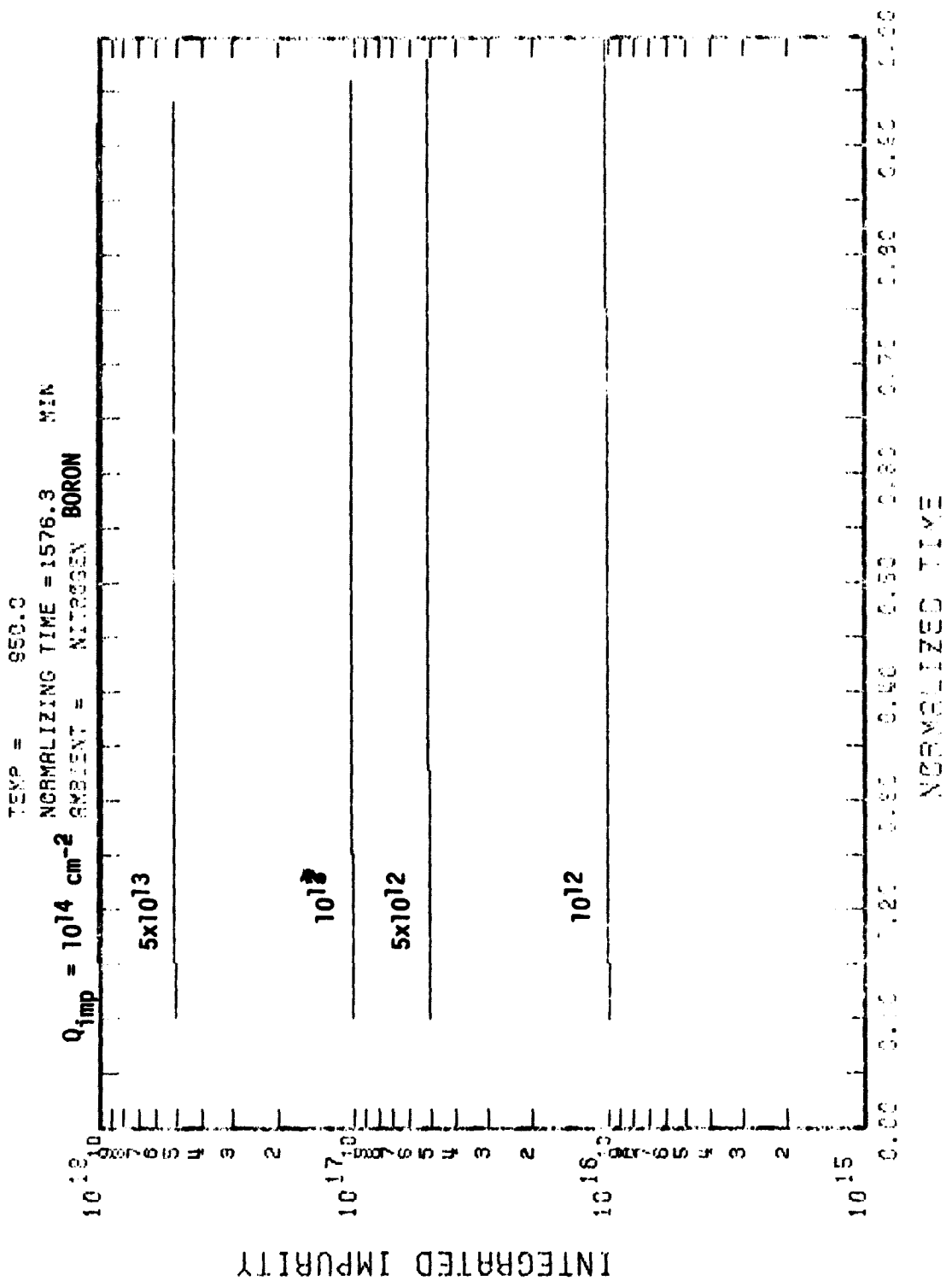


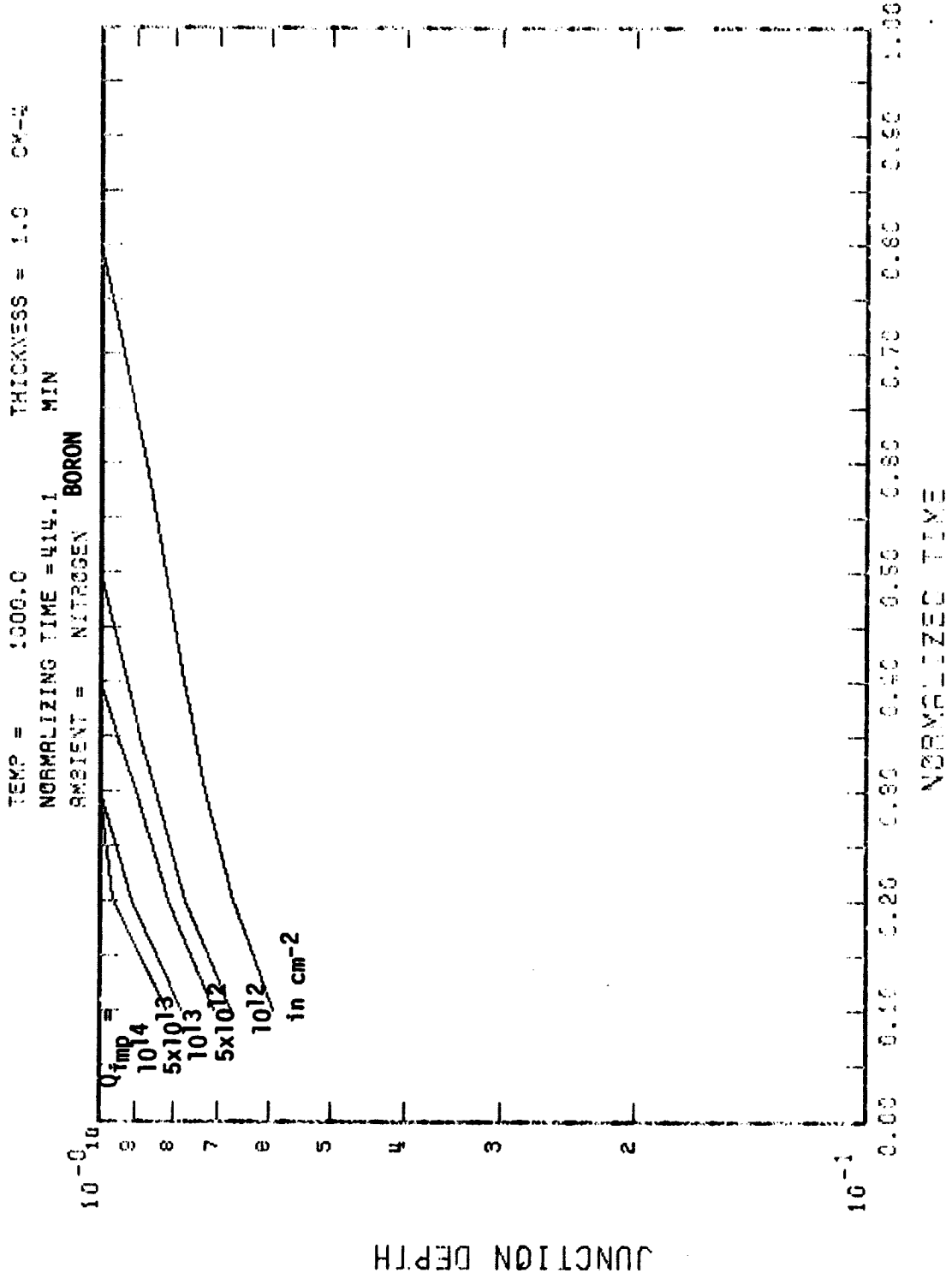




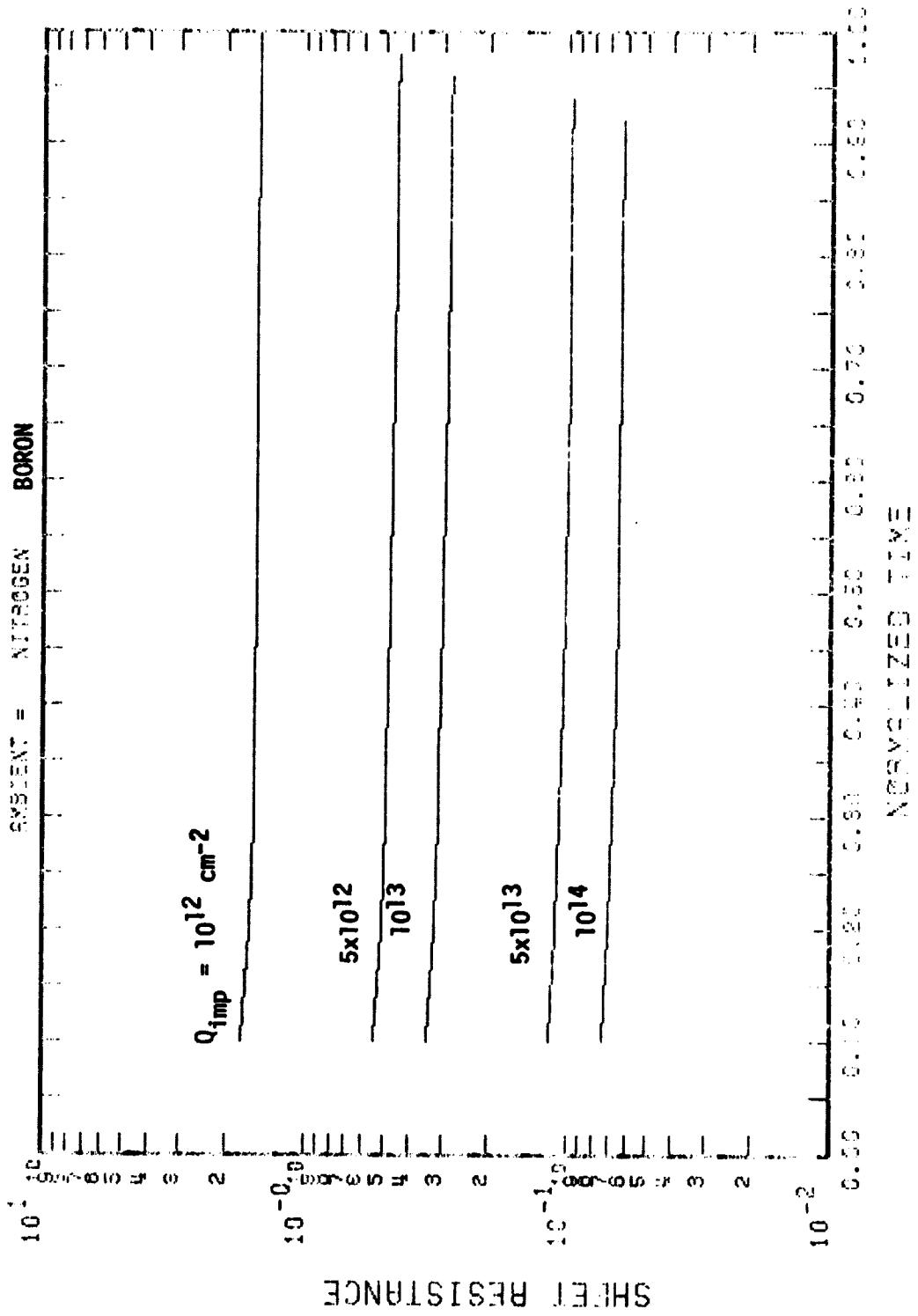


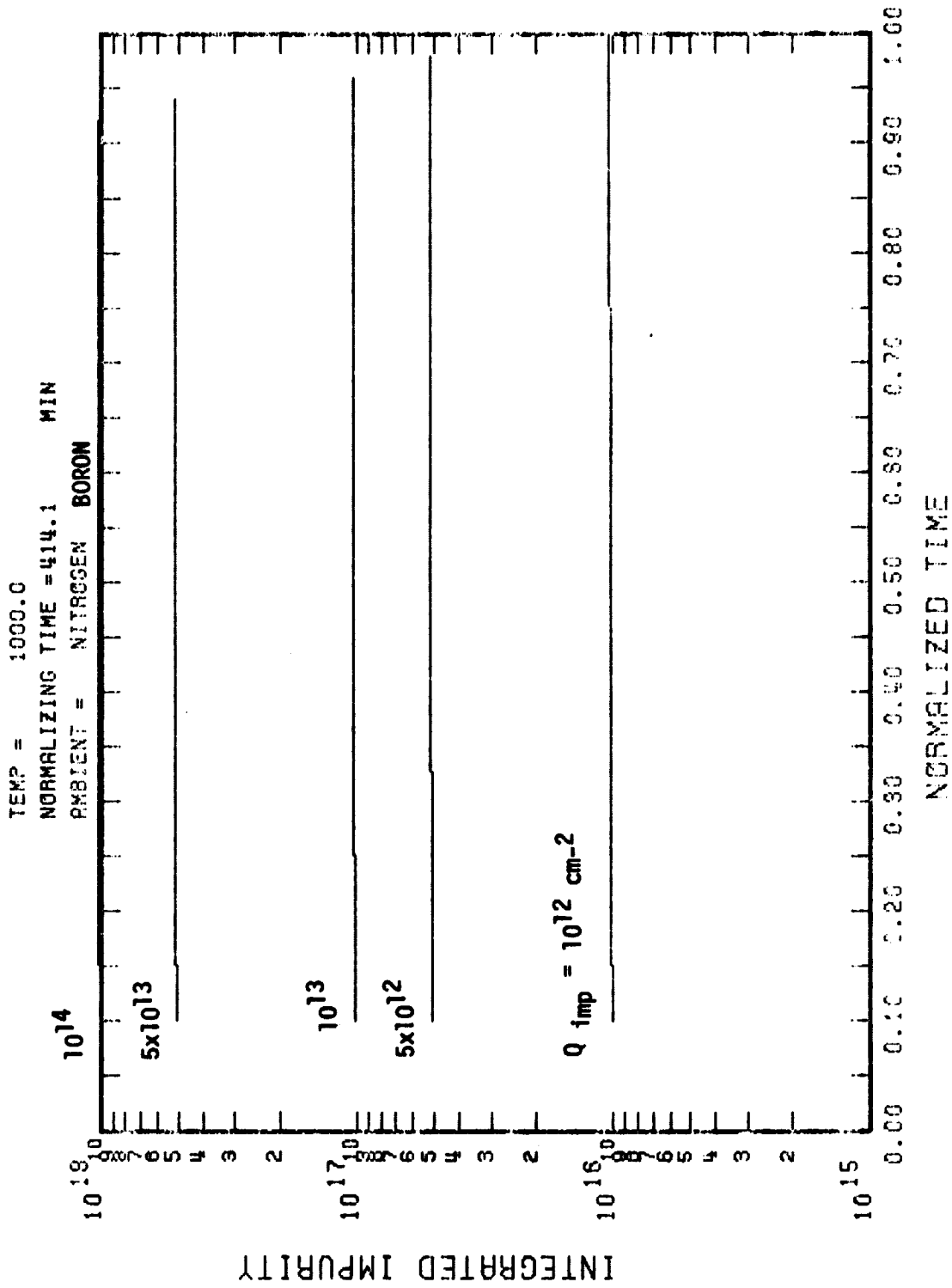


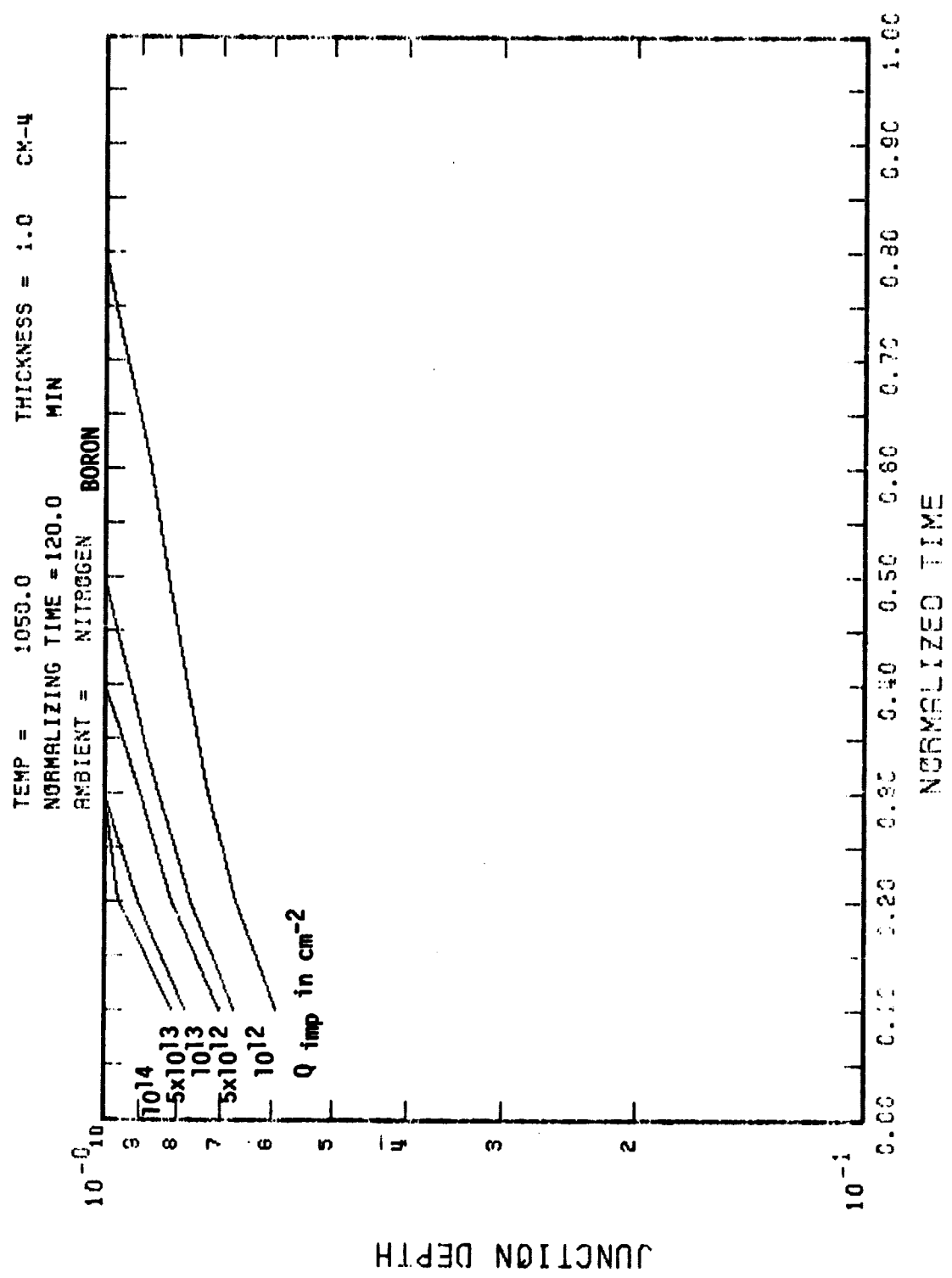




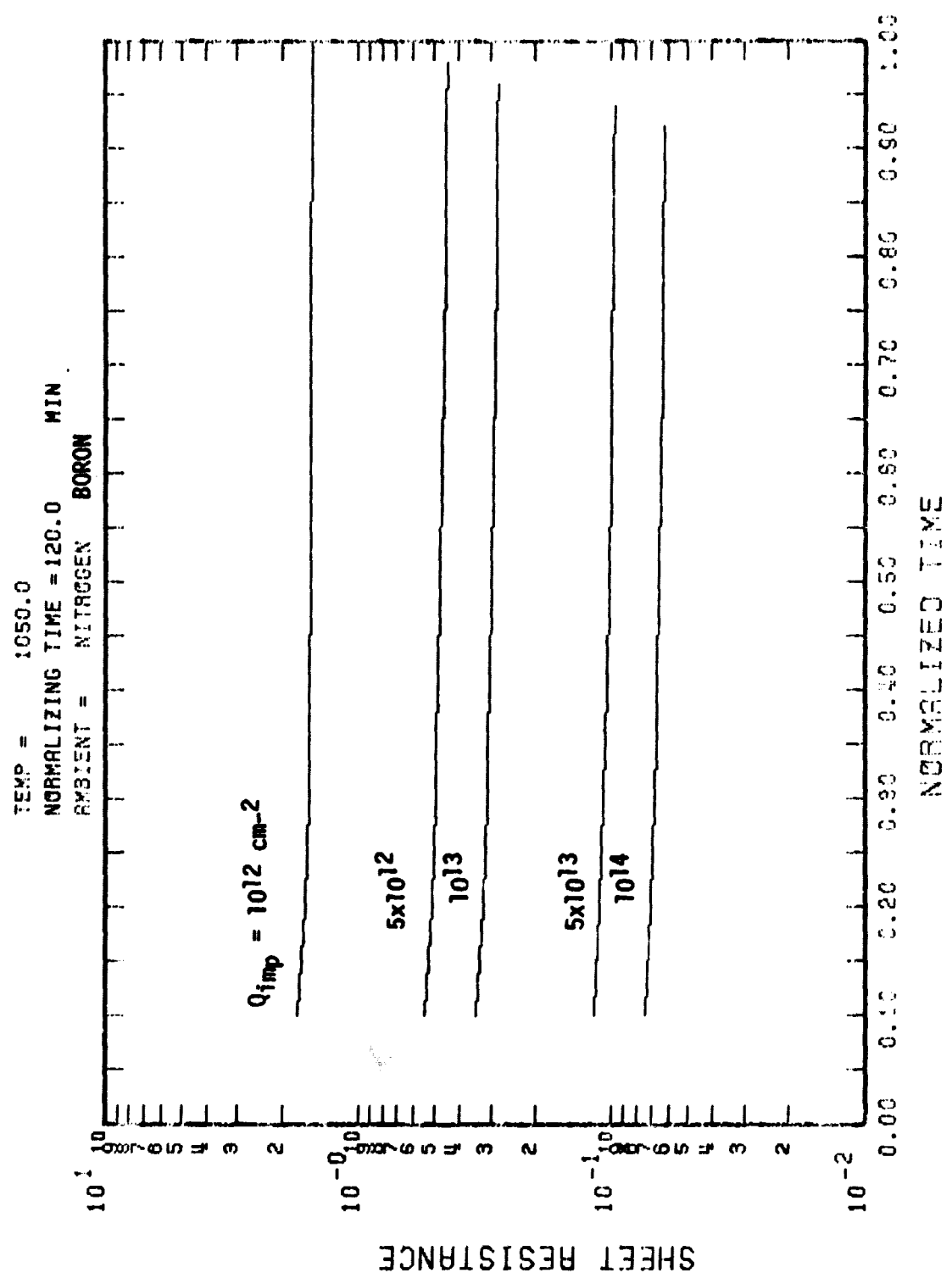
TEMP = 1000.0
NORMALIZING TIME = 414.1 MIN
SYSTEM = NITROGEN BORON

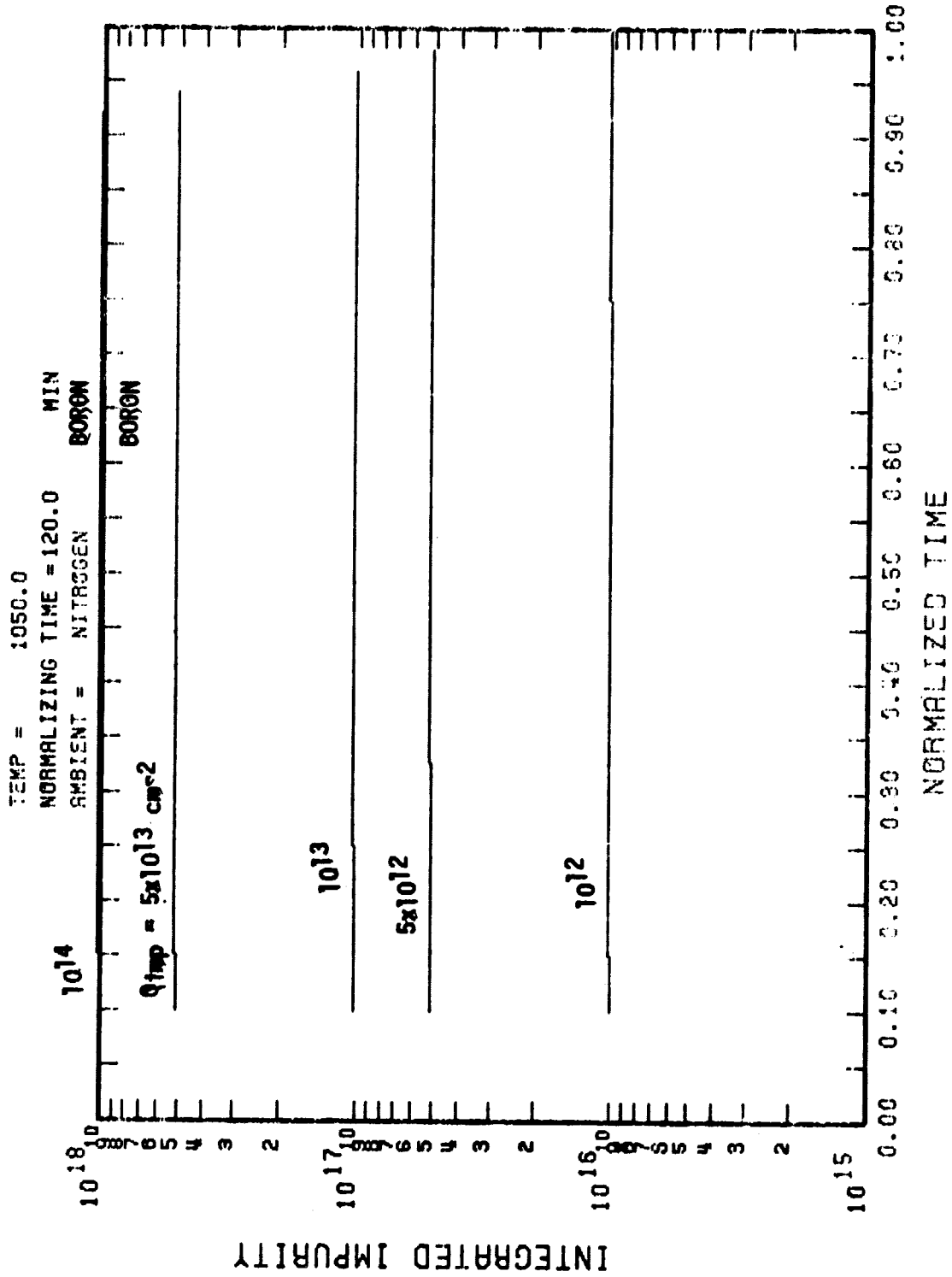




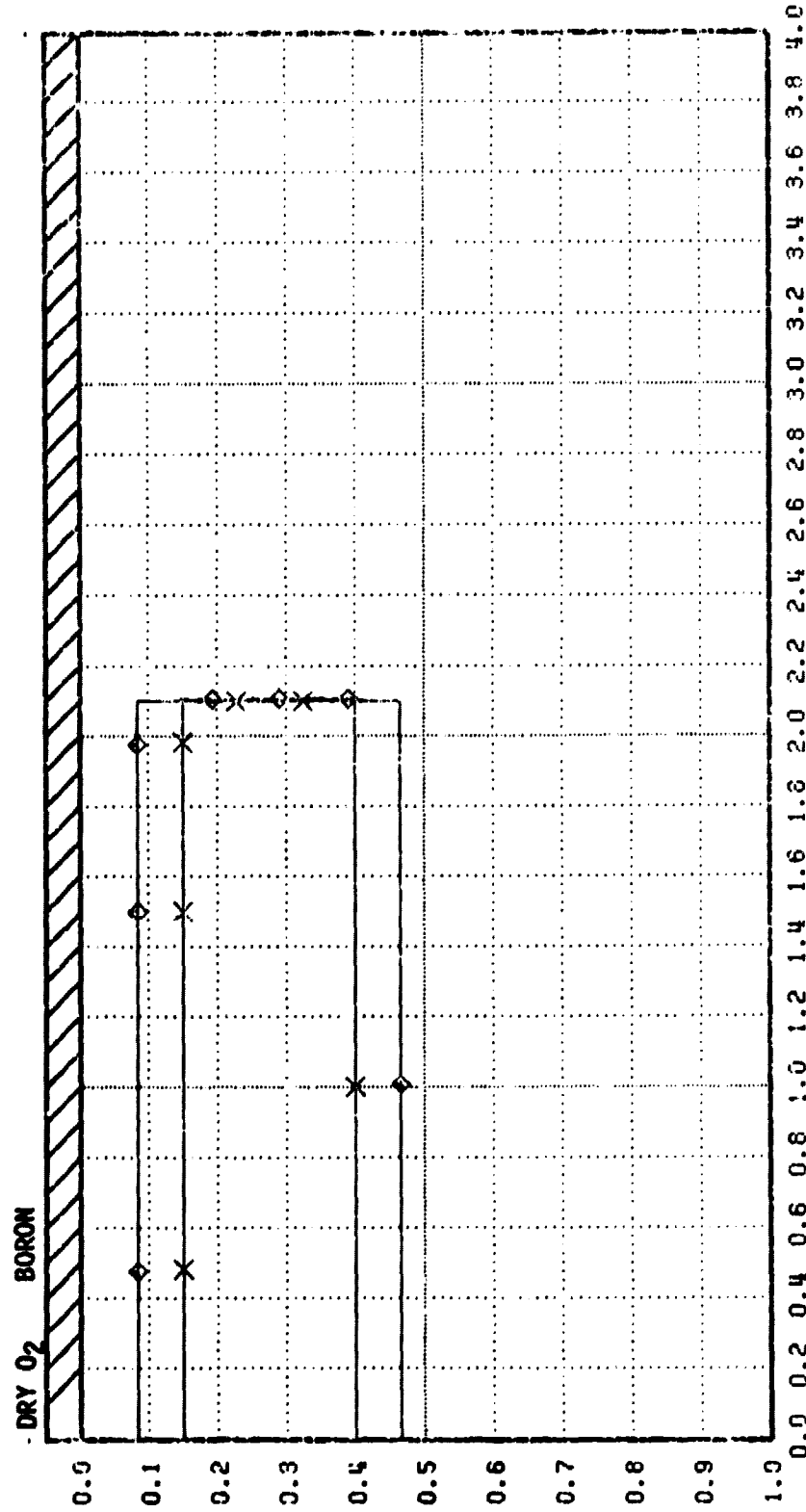


6





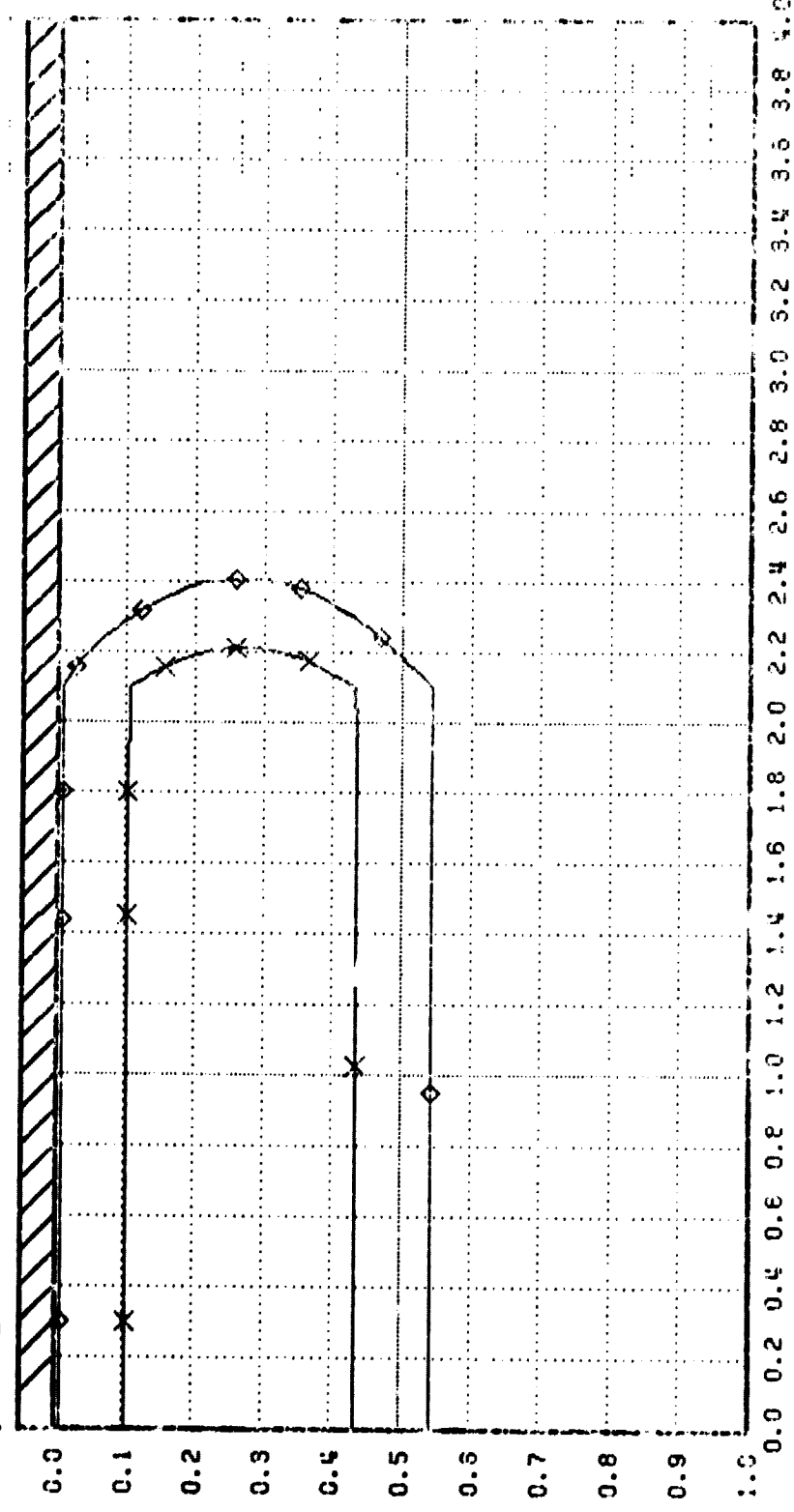
λ^2 = 0.0000
 TEMPERATURE = 1000.
 TIME STEP = 0
 TIME = 0.00
 □ - 1.0E20
 ○ - 1.0E19
 ▲ - 1.0E18
 + - 1.0E17
 X - 1.0E16
 ◇ - 1.0E15



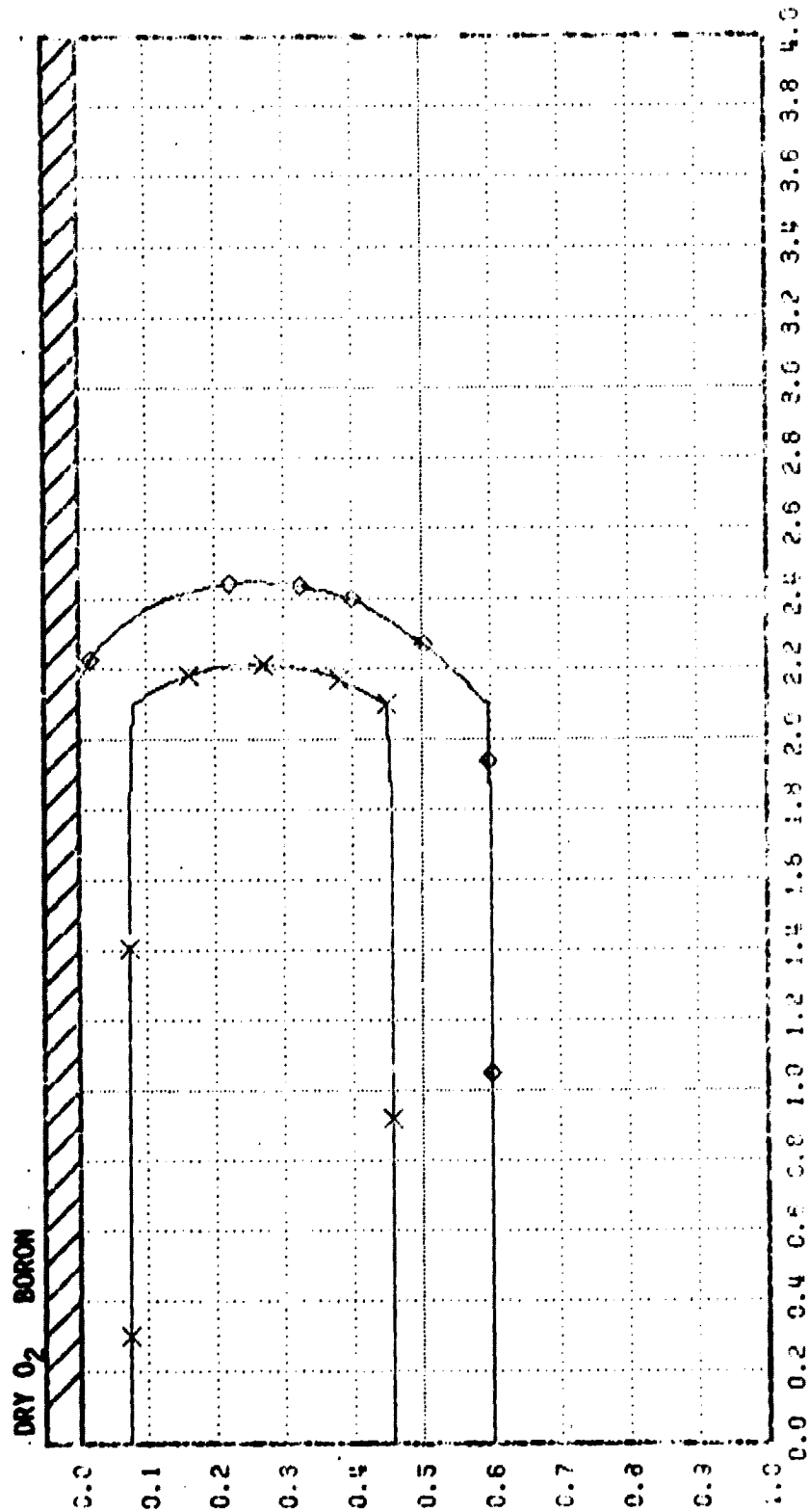
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χ^2 = 0.0000
TEMPERATURE = 1000.
TIME STEP = 20
TIME = 1440.00
DRY O₂ BORON

□ - 1.0E20
○ - 1.0E18
△ - 1.0E16
+ - 1.0E17
x - 1.0E18
◇ - 1.0E15



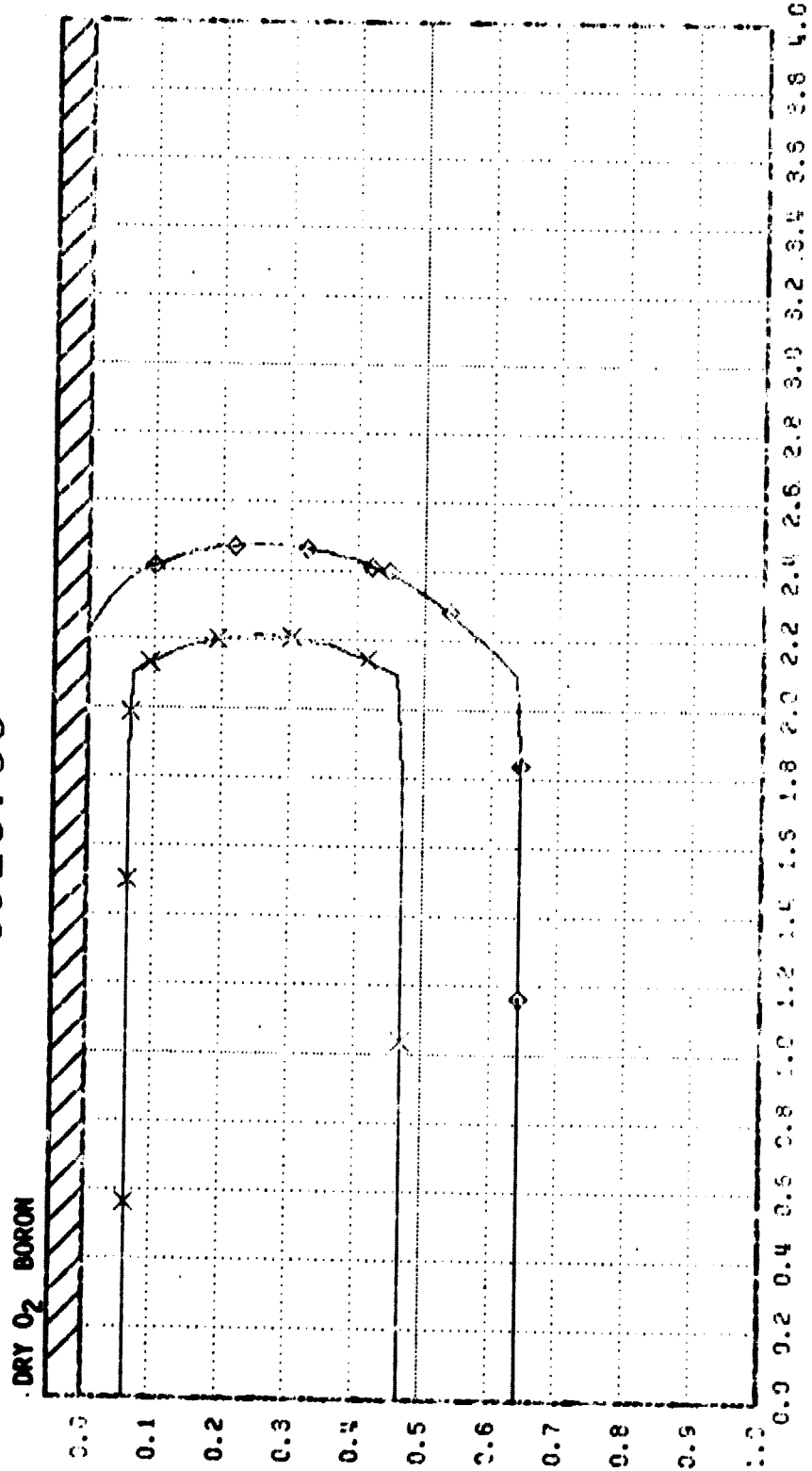
λ^2 = 1.0E20
 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 40
 = 2880.00



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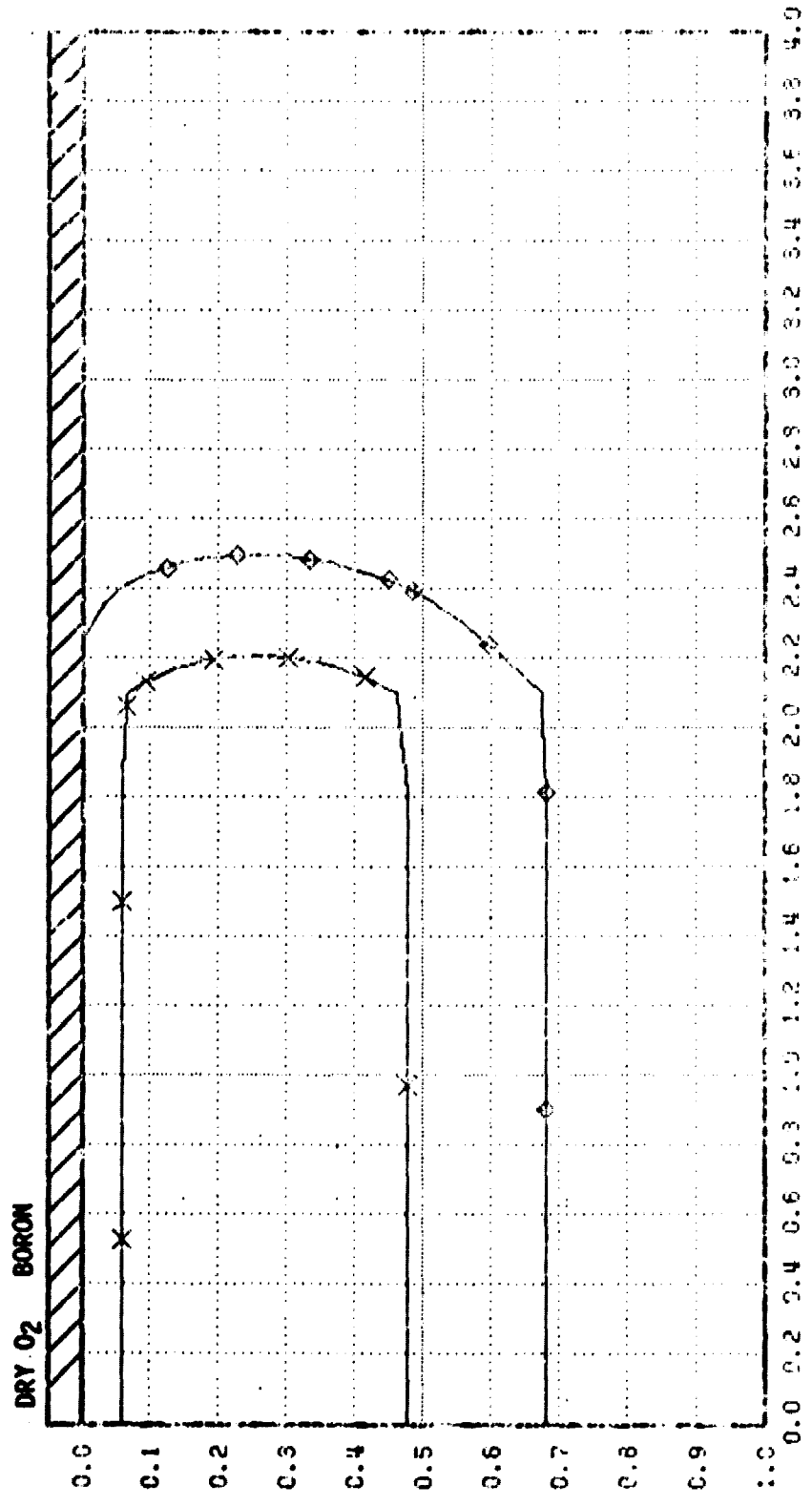
A 22

X^2 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 60
 = 4320.00



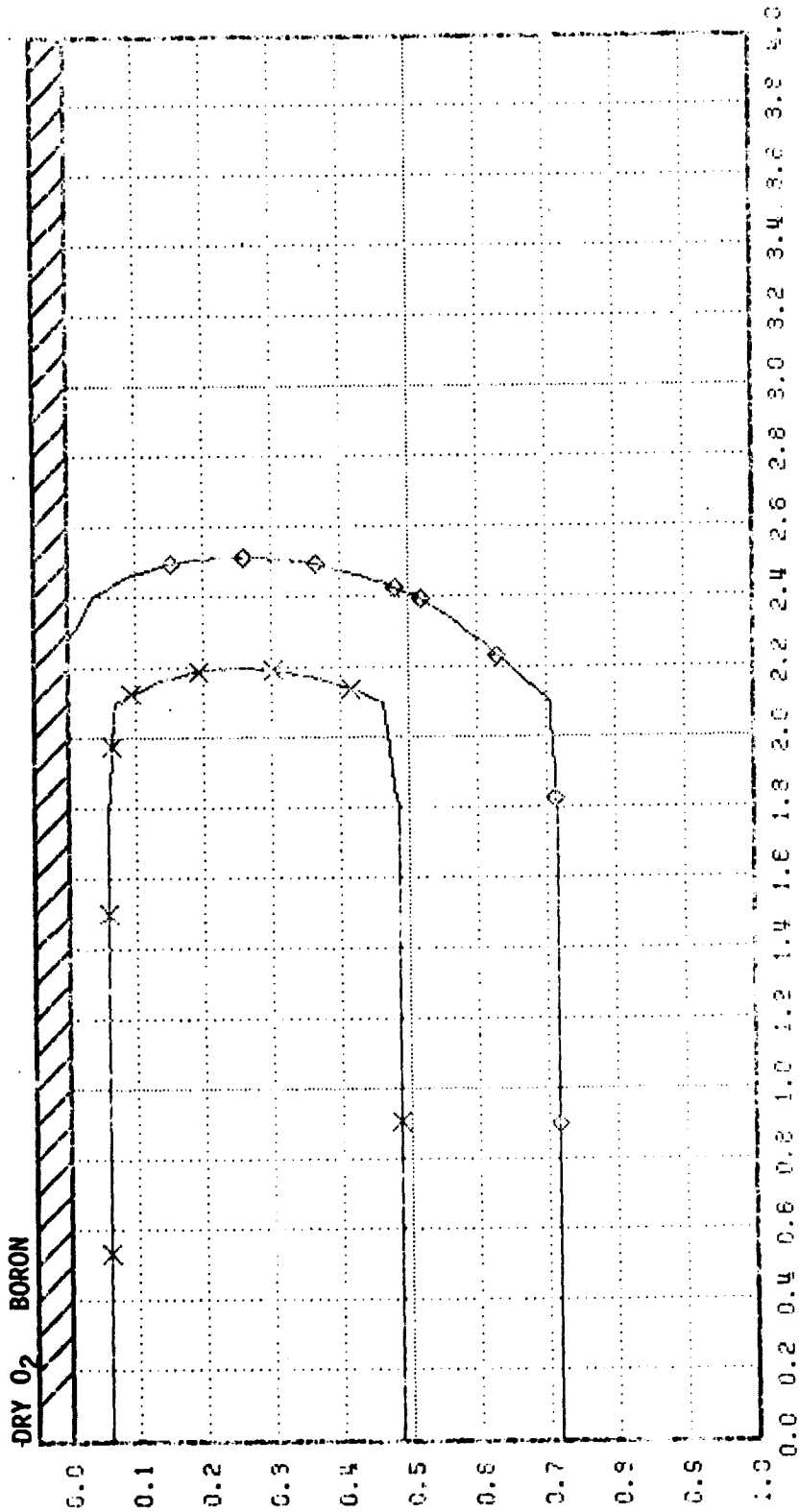
χ^2 = 0.0000
 TEMPERATURE = 1000.
 TIME STEP = 80
 TIME = 5760.00

E - 1.0E20
 G - 1.0E19
 A - 1.0E18
 + - 1.0E17
 X - 1.0E16
 - 1.0E15



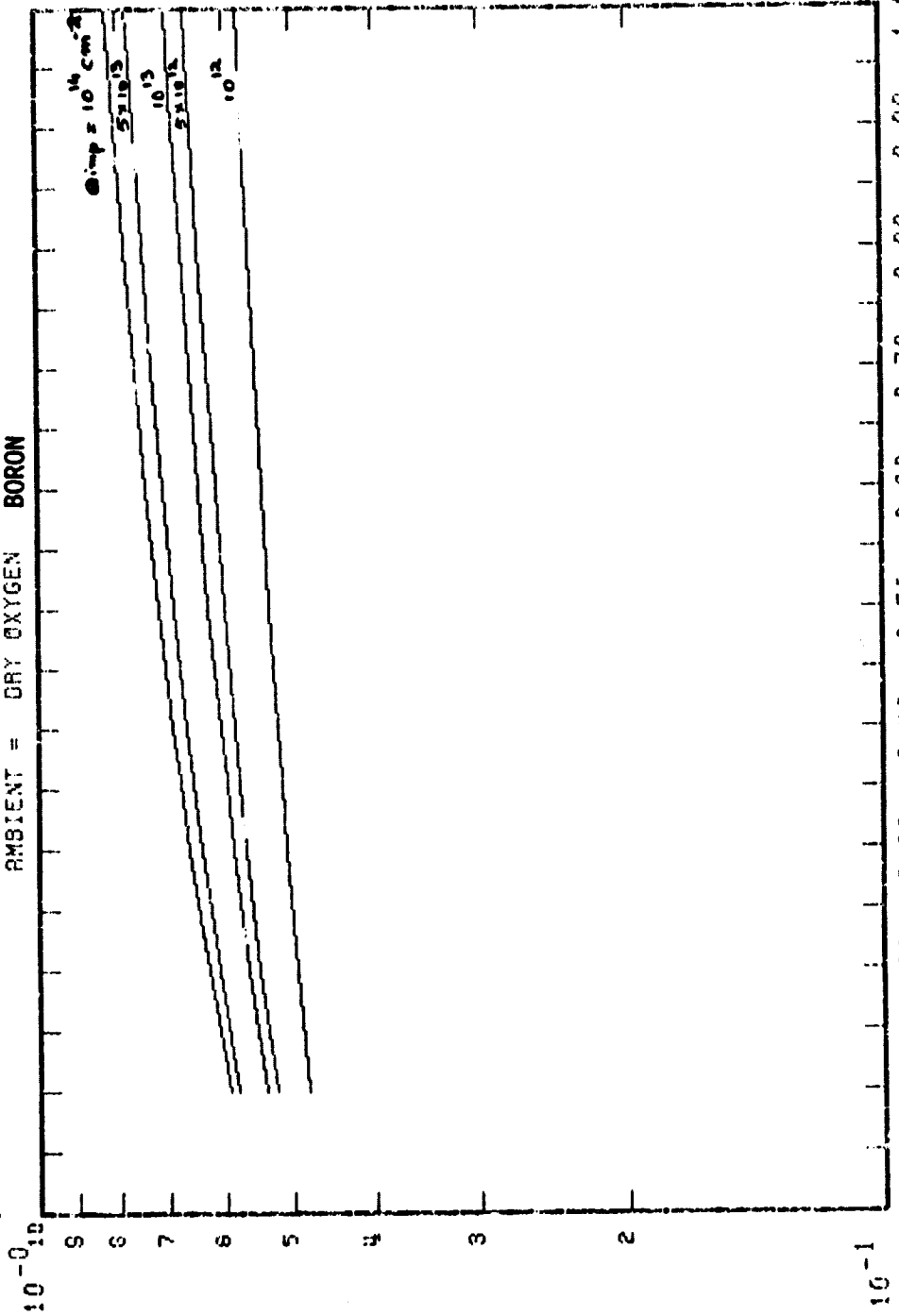
λ^2 = 0.0000
 TEMPERATURE = 1000.
 TIME STEP = 100
 TIME = 7200.00

□ - 1.0E20
 ○ - 1.0E19
 ▲ - 1.0E18
 + - 1.0E17
 x - 1.0E16
 ◇ - 1.0E15

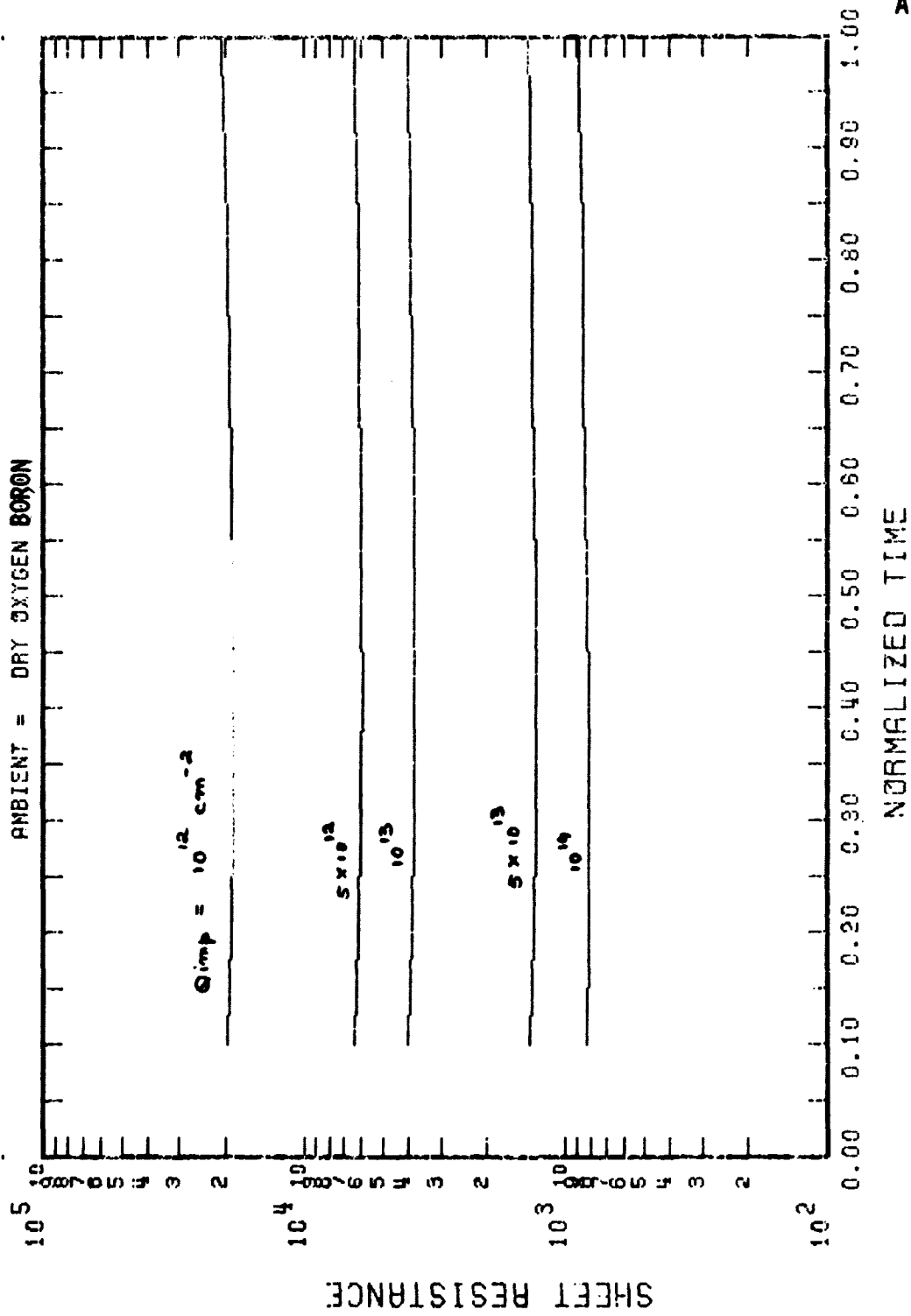


5

TEMP = 900.0 THICKNESS = 0.0 CM-H
NORMALIZING TIME = 1400.0 MIN
AMBIENT = DRY OXYGEN BORON

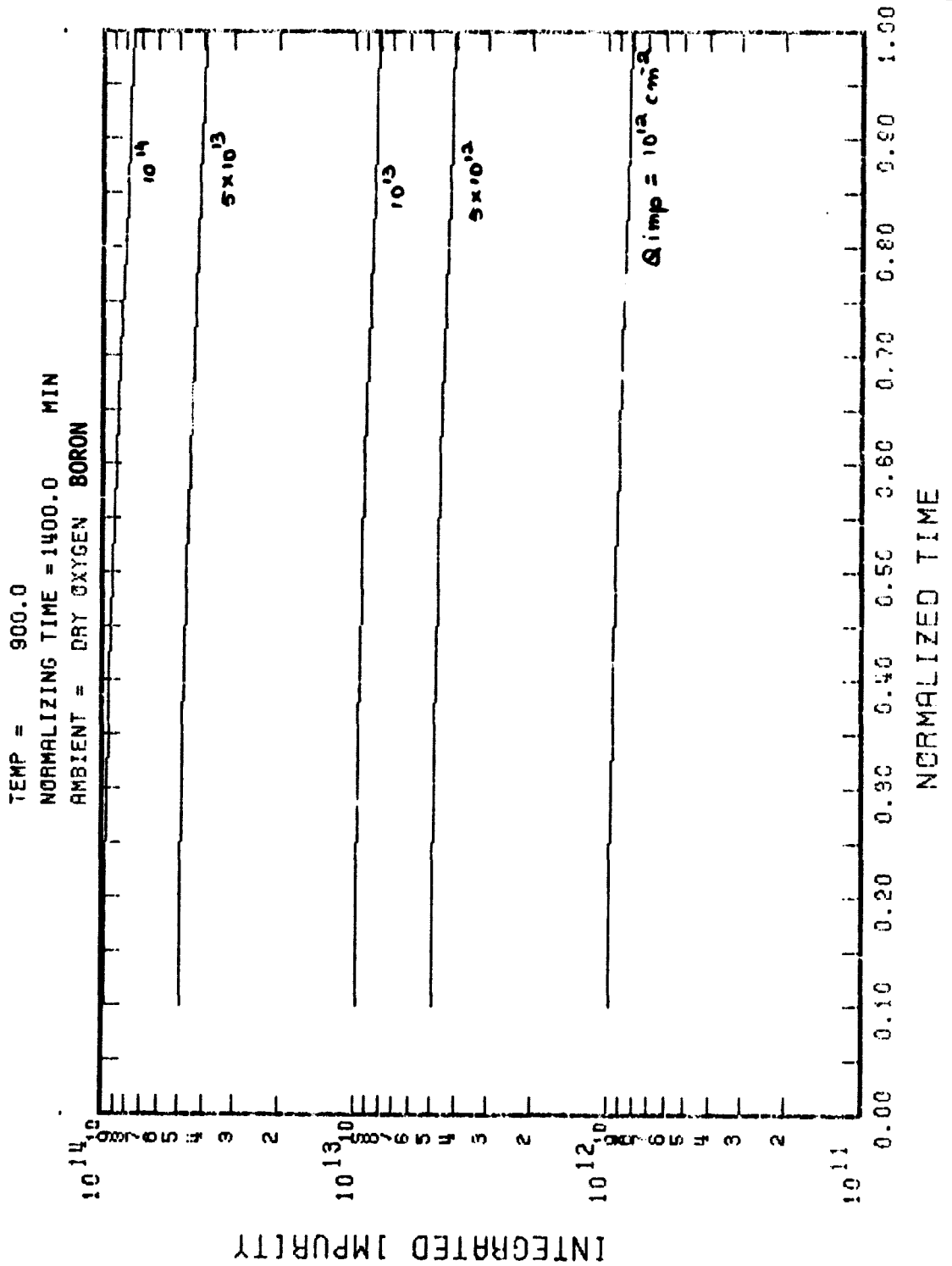


TEMP = 900.0
NORMALIZING TIME = 1400.0 MIN
AMBIENT = DRY OXYGEN BORON

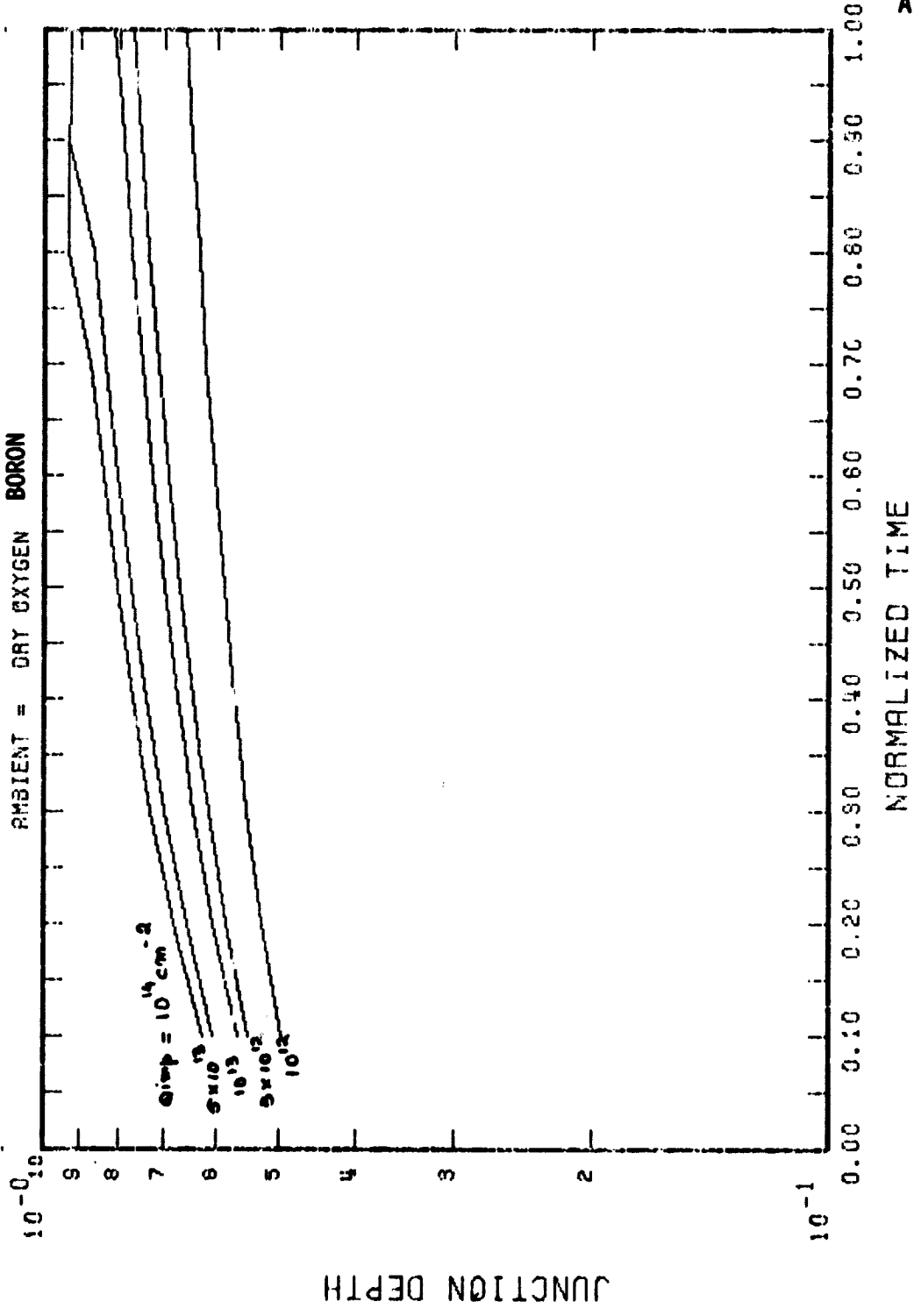


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A 27

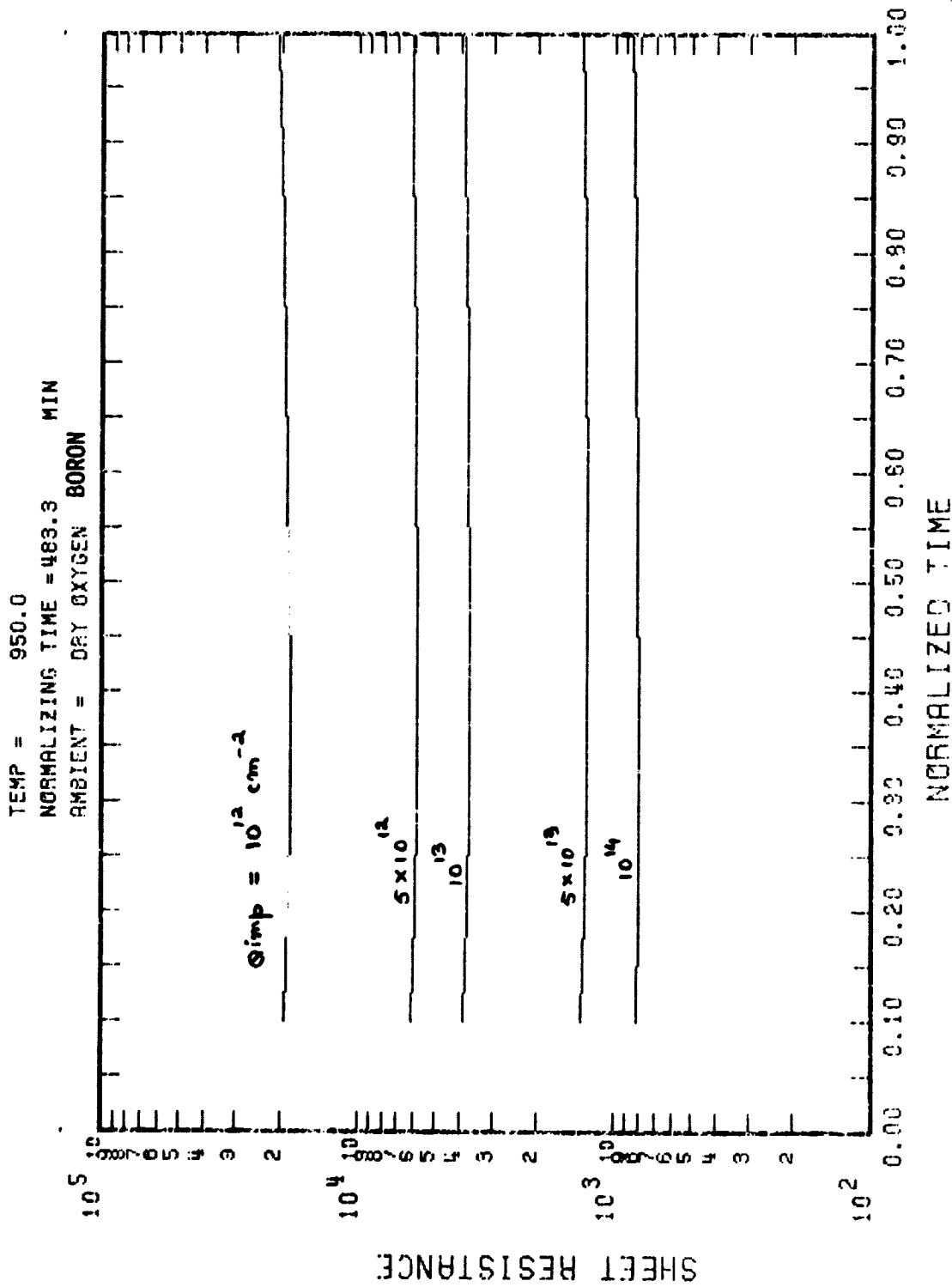


TEMP = 950.0 THICKNESS = 0.0 CM-4
NORMALIZING TIME = 483.3 MIN
AMBIENT = DRY OXYGEN BORON

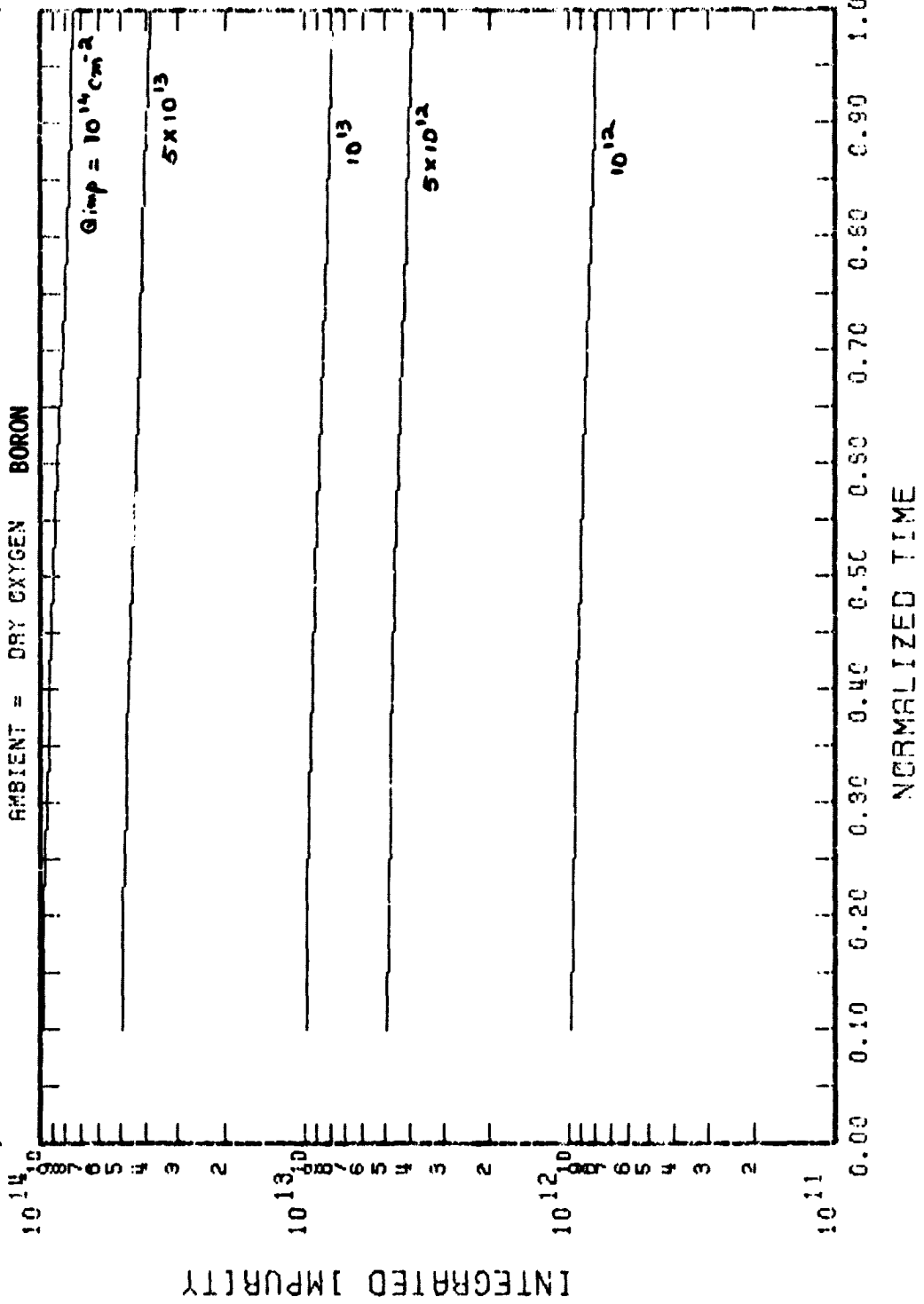


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A 29



TEMP = 950.0
NORMALIZING TIME = 483.3 MIN
AMBIENT = DRY OXYGEN BORON



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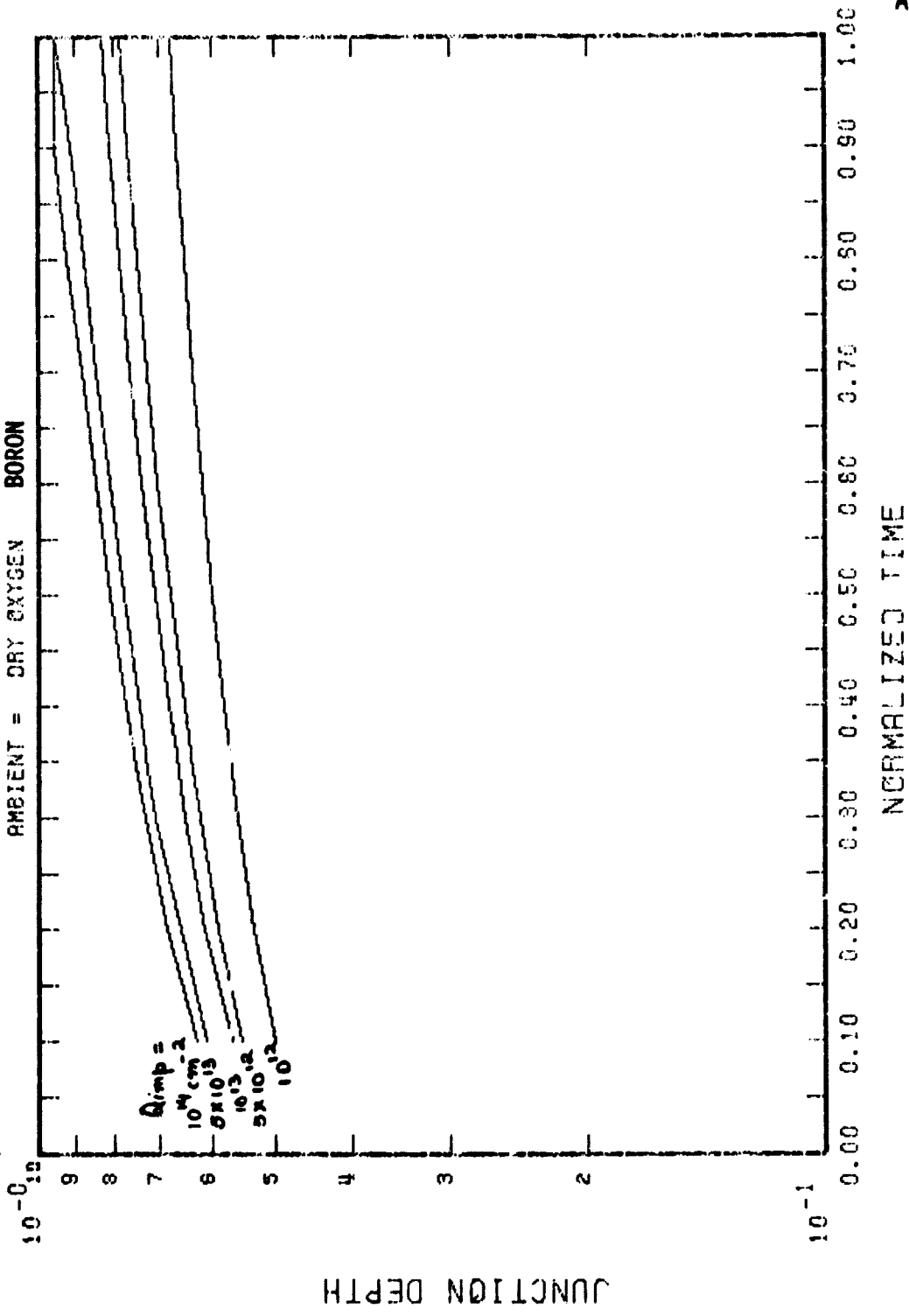
31

A 31

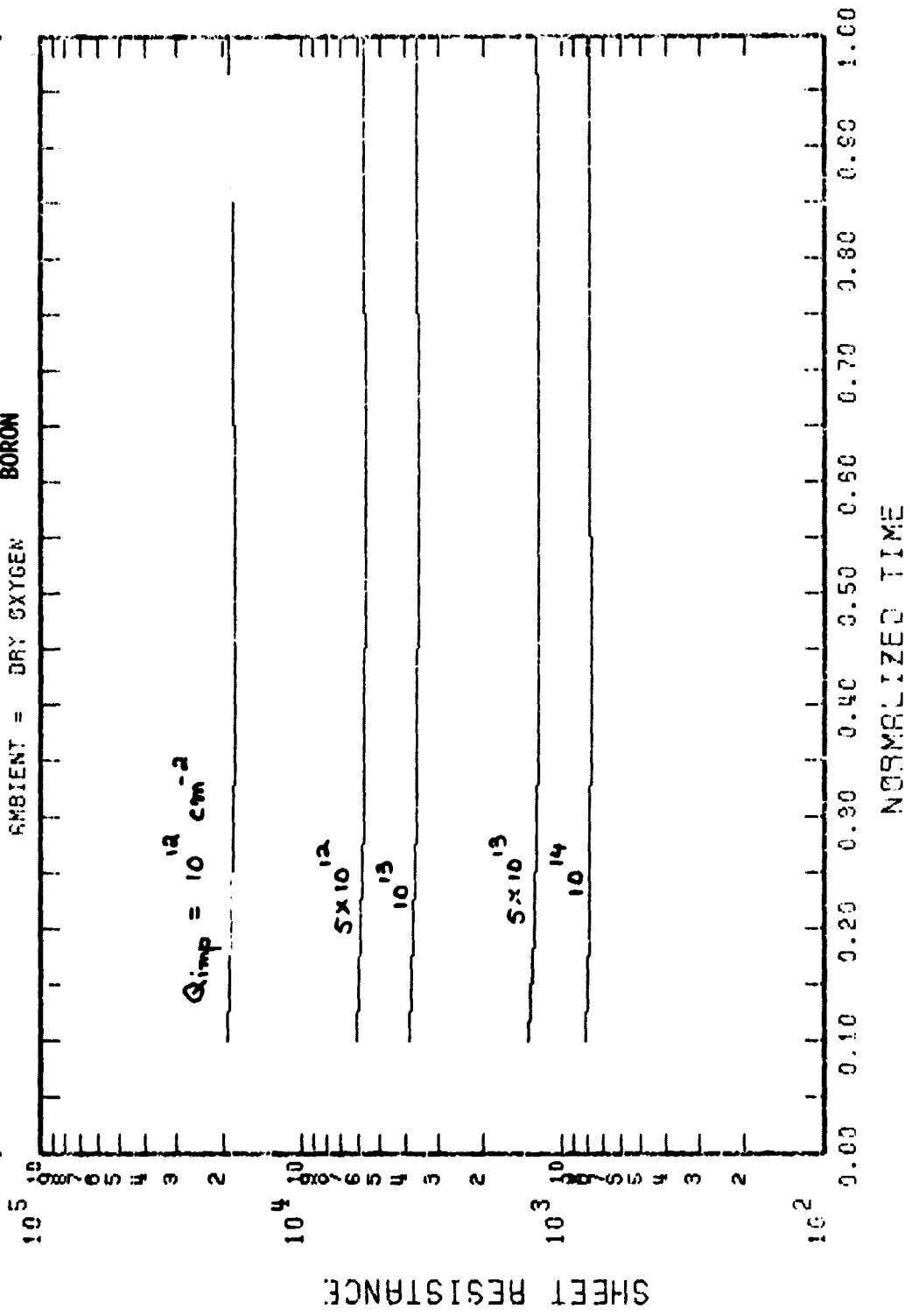
TEMP = 1000.C THICKNESS = 0.0 CM-U

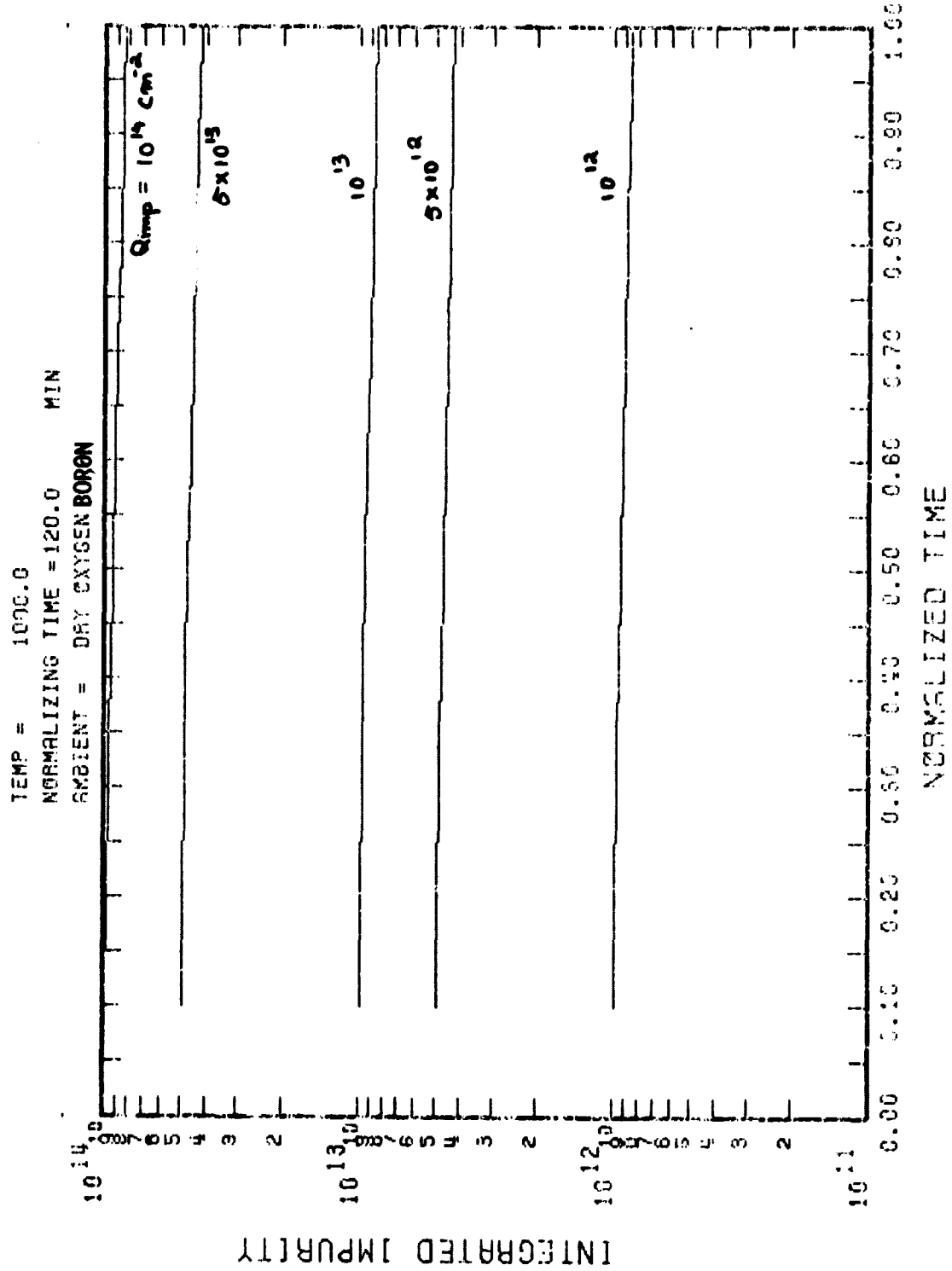
NORMALIZING TIME = 120.0 MIN

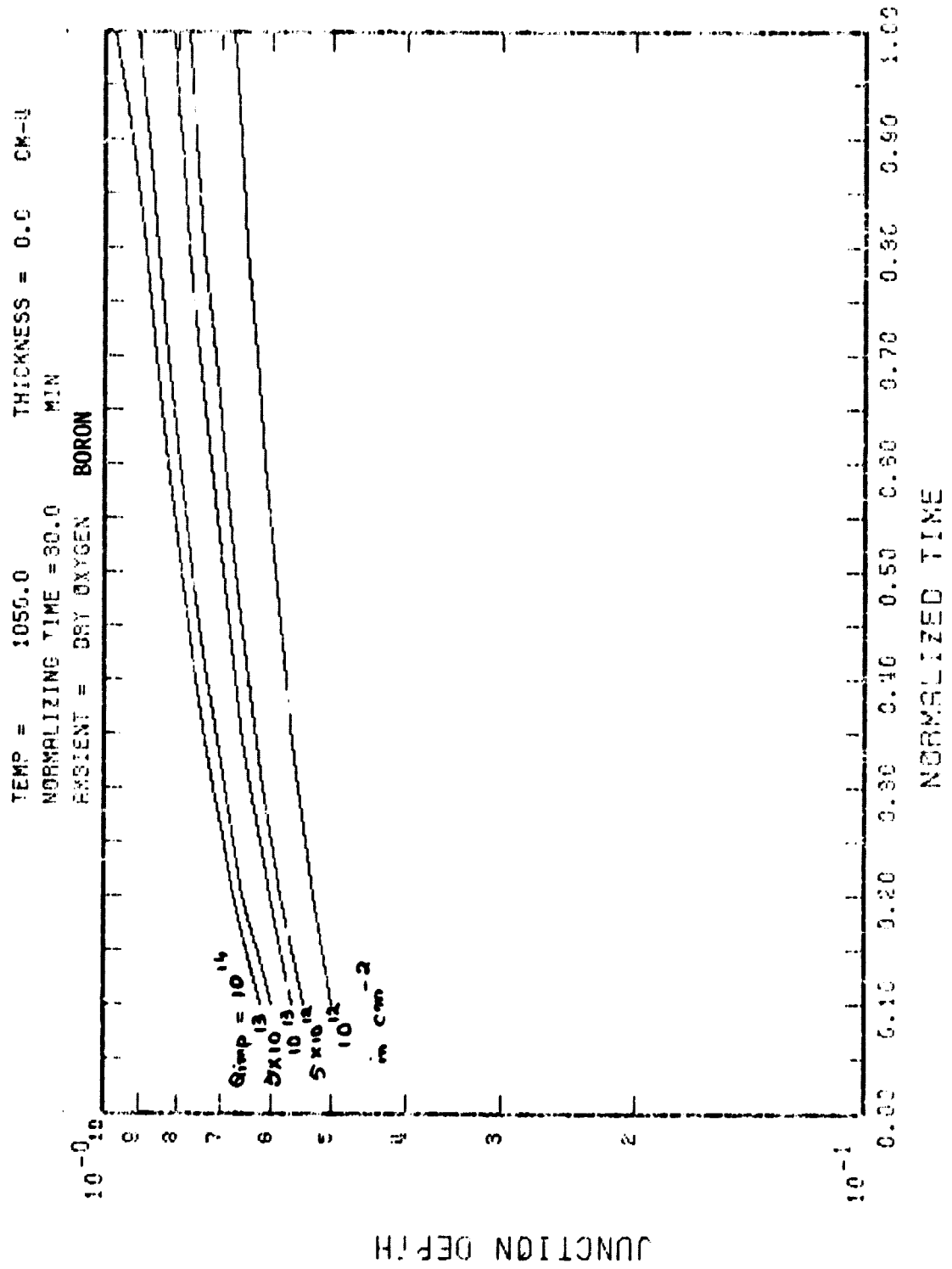
AMBIENT = DRY OXYGEN BORON



TEMP = 1000.0
 NORMALIZING TIME = 120.0 MIN
 AMBIENT = DRY OXYGEN BORON

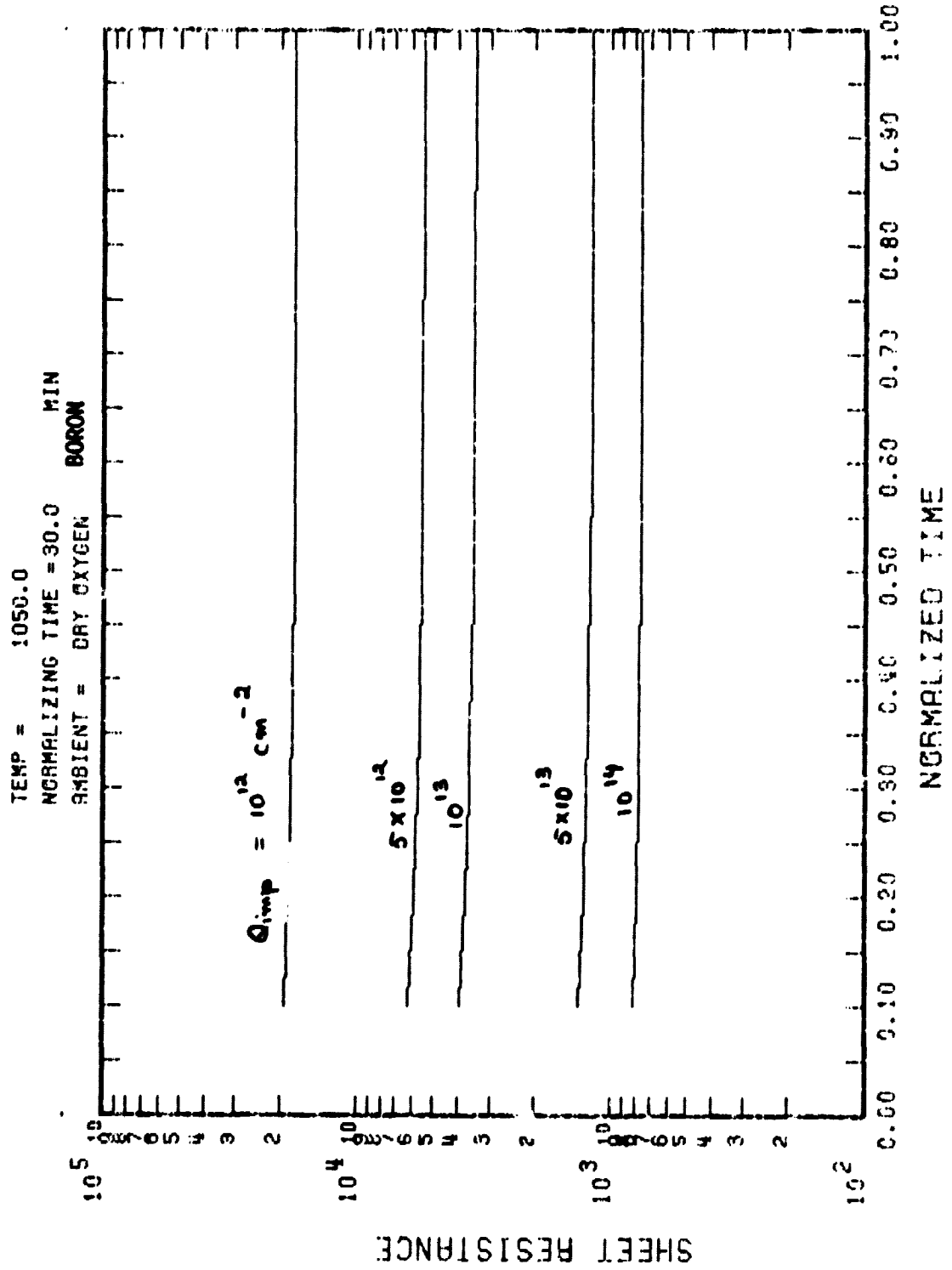




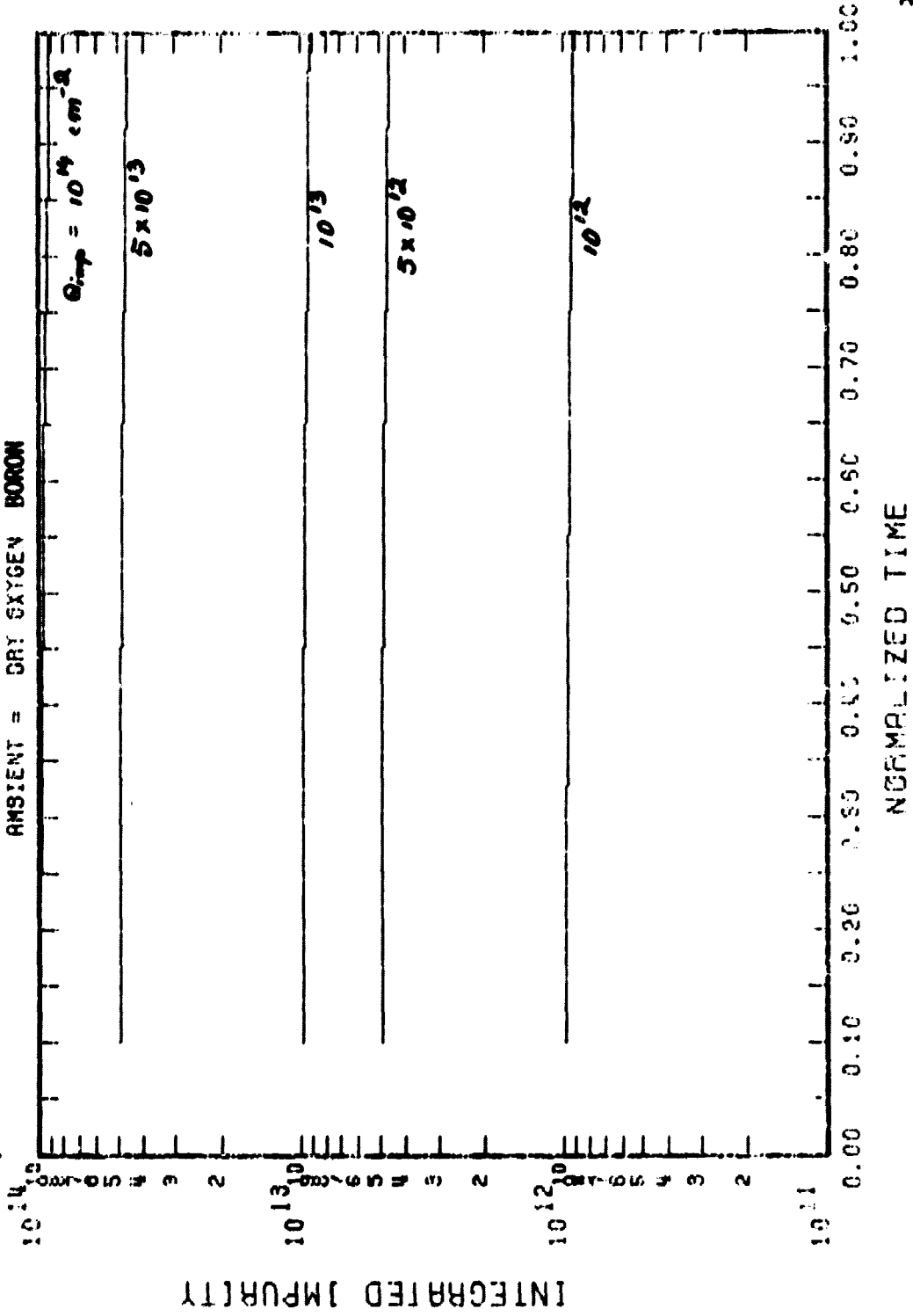


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A 35



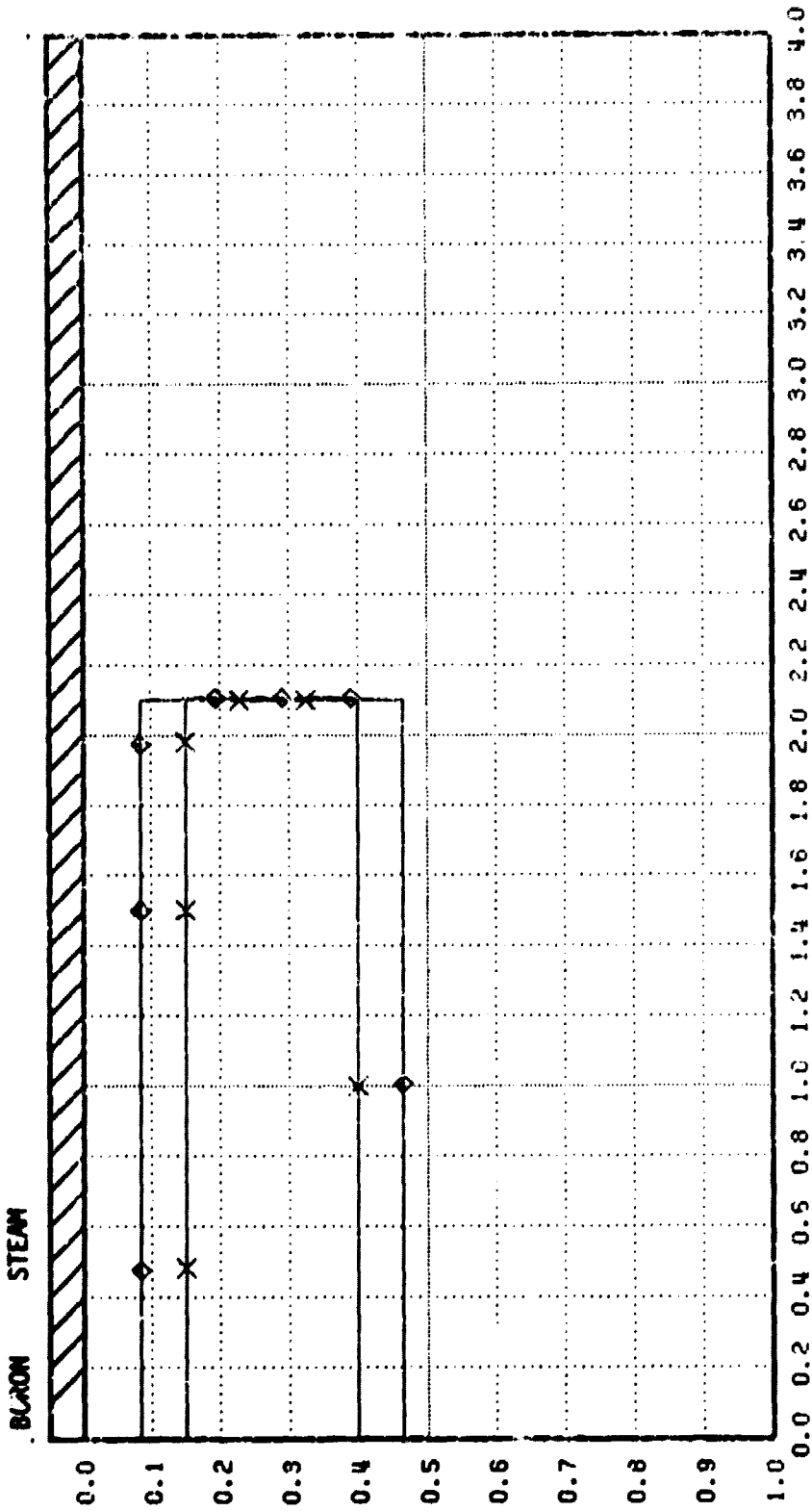
TEMP = 1050.0
NORMALIZING TIME = 30.0 MIN
AMBIENT = DRY OXYGEN BORON



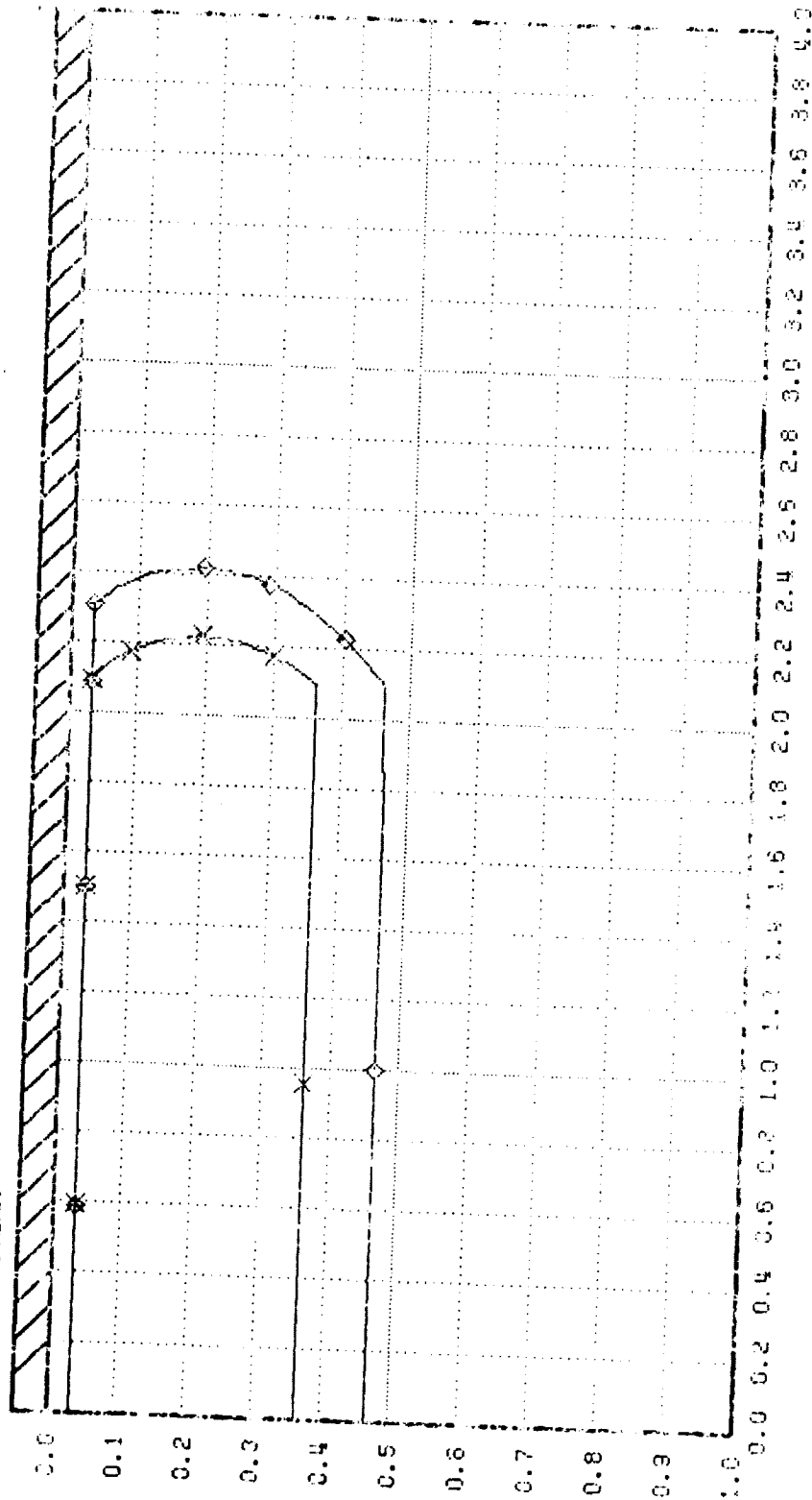
3)

$\lambda^2 = 0.0000$
 TEMPERATURE = 1000.
 TIME STEP = 0
 TIME = 0.00
 BURN STEAM

□ - 1.0E20
 ○ - 1.0E19
 △ - 1.0E18
 + - 1.0E17
 X - 1.0E16
 ◇ - 1.0E15



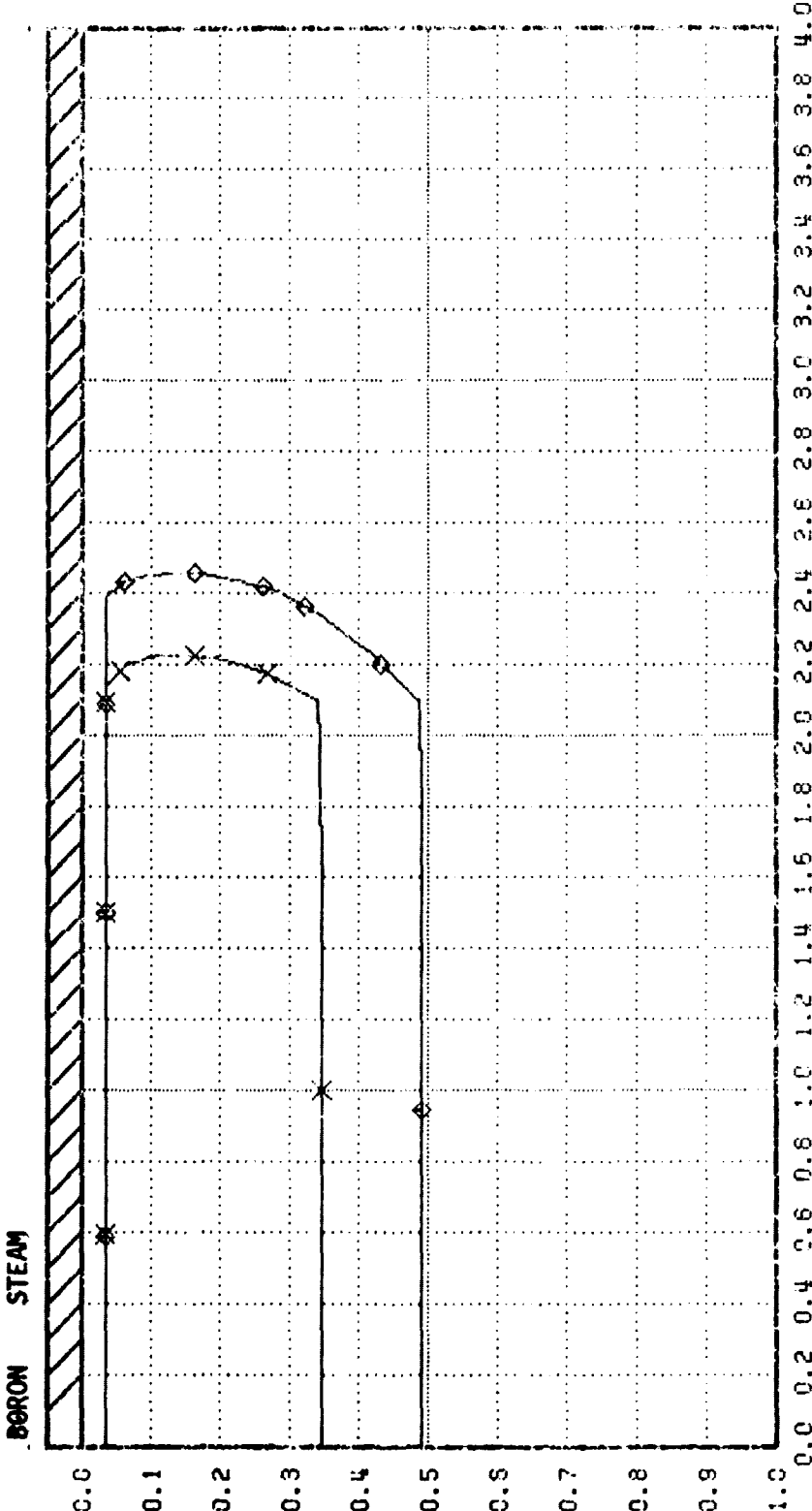
TEMPERATURE = 0.0000
 TEMPERATURE = 1000.
 TIME STEP = 20
 TIME = 1140.00
 BORON STEAM

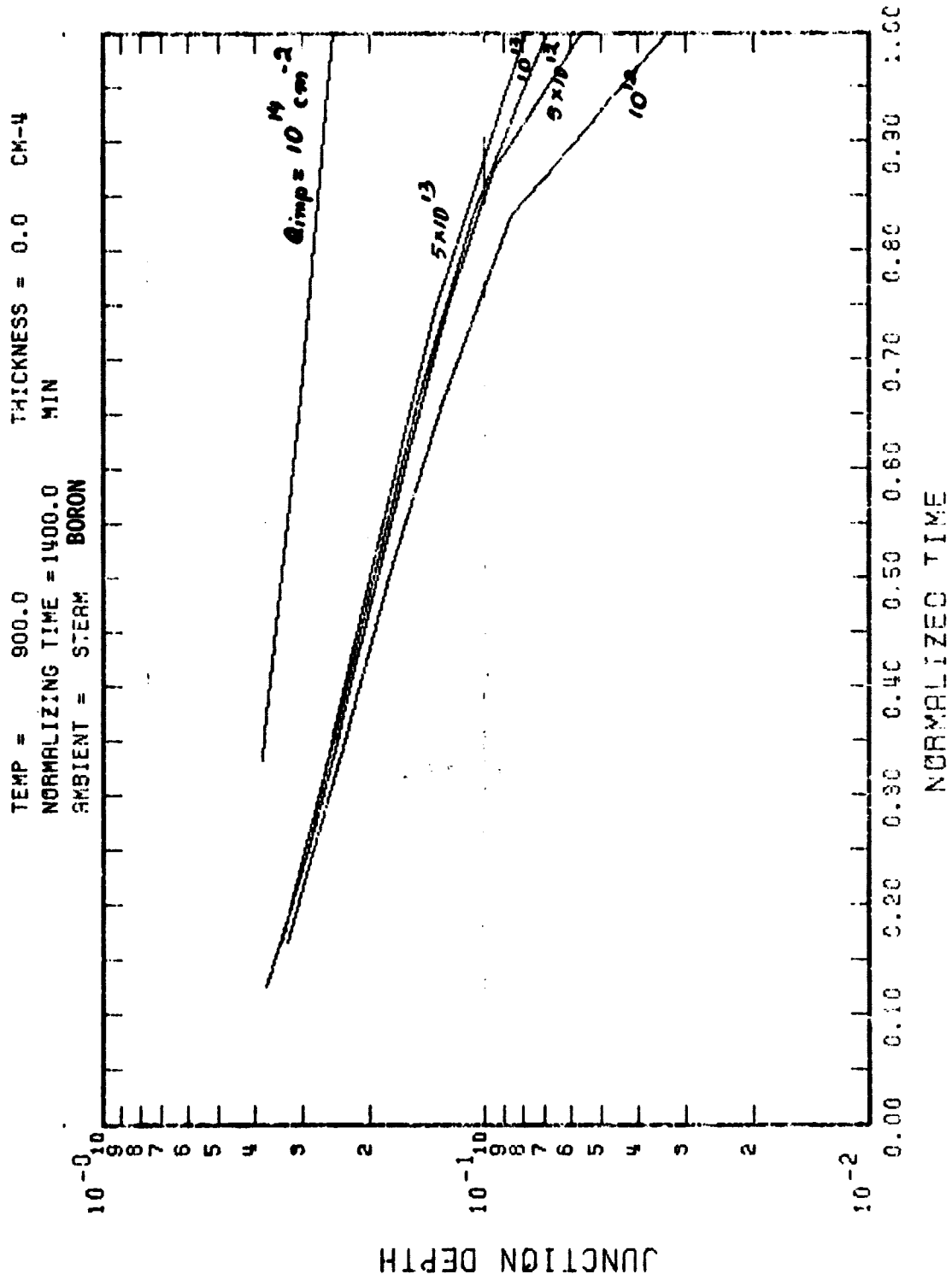


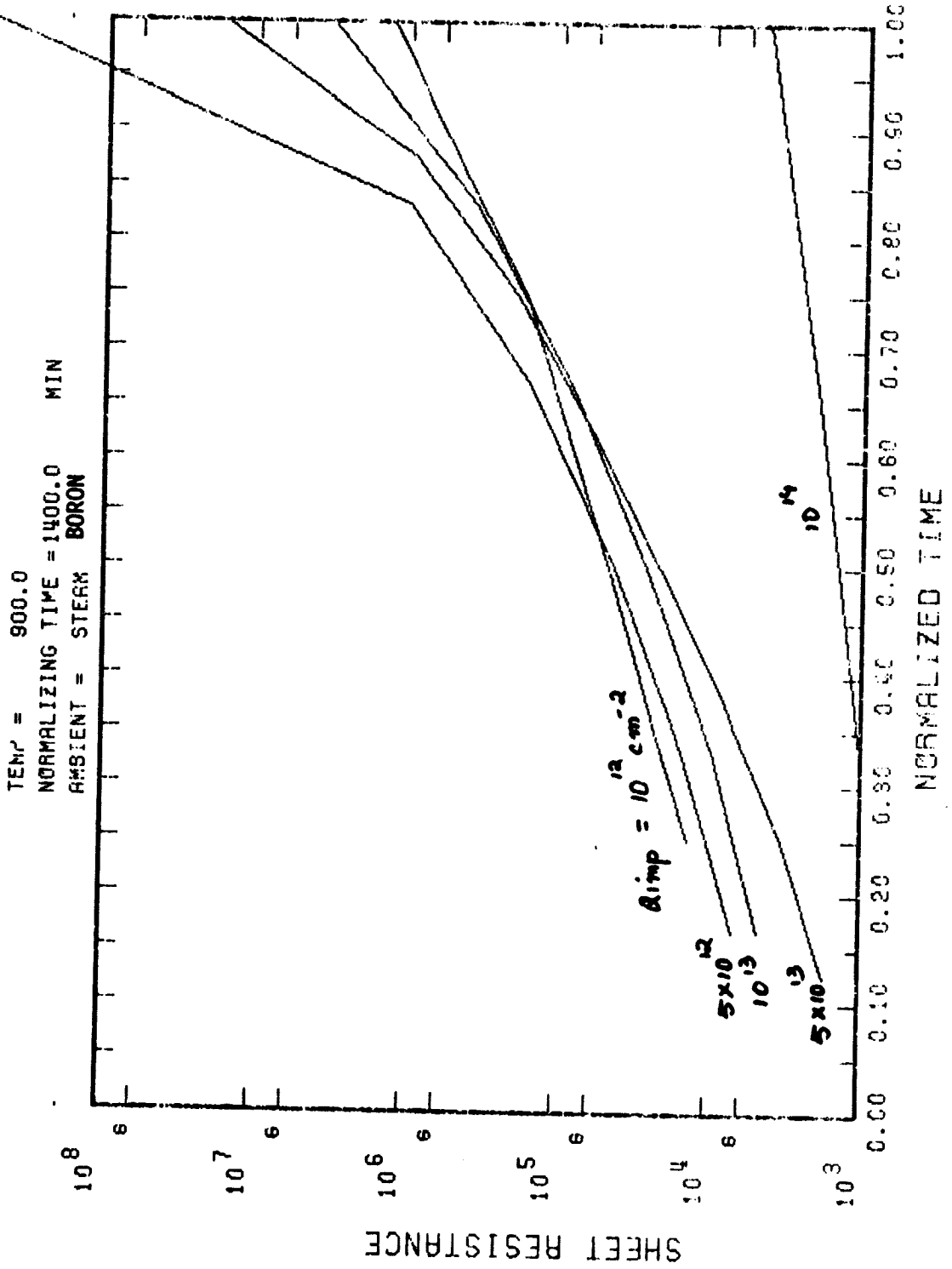
37

λ^2 = 0.0000
 TEMPERATURE = 1000.
 TIME STEP = 40
 TIME = 2880.00

E - 1.0E20
 O - 1.0E19
 A - 1.0E18
 + - 1.0E17
 X - 1.0E16
 D - 1.0E15

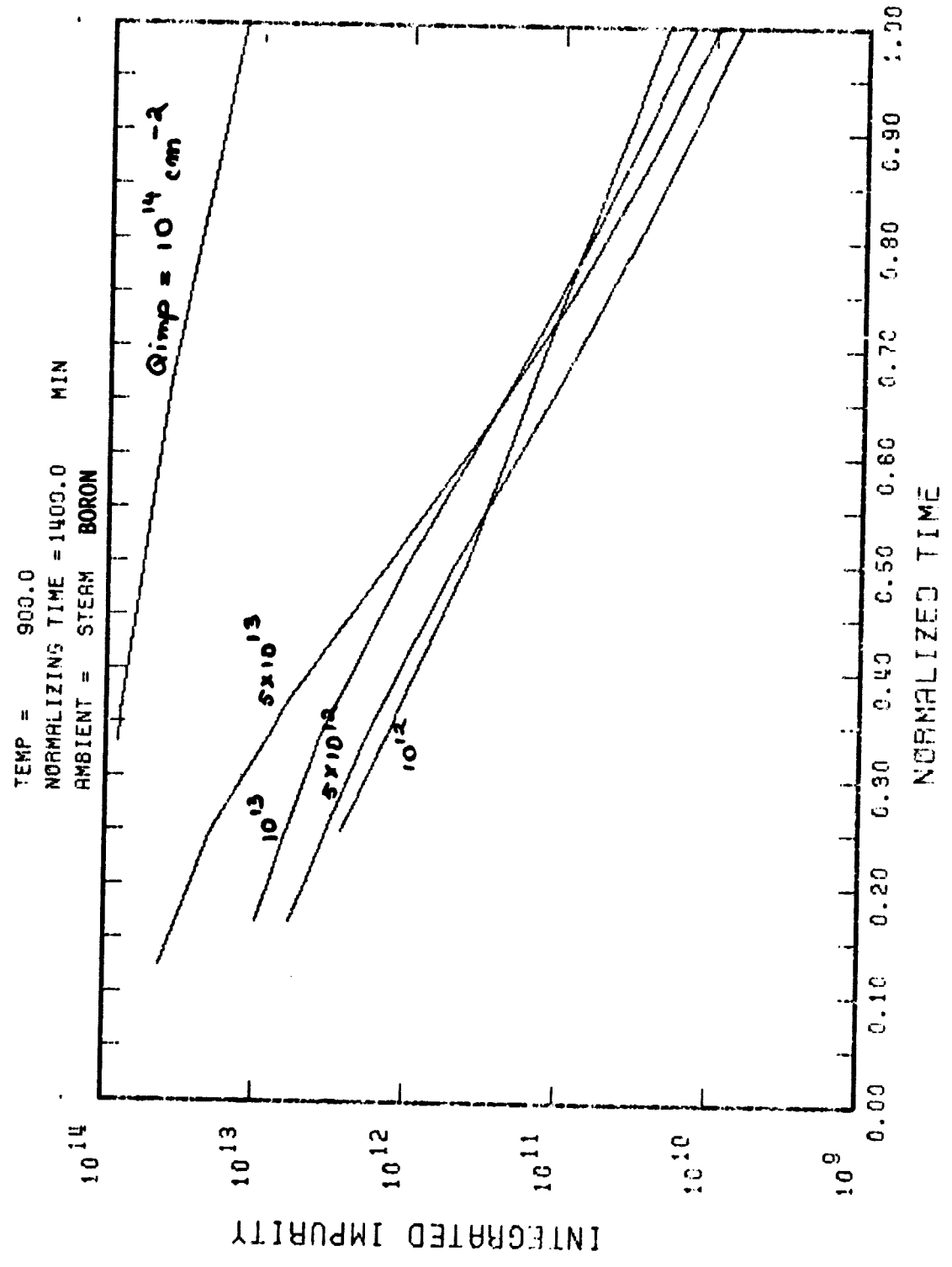




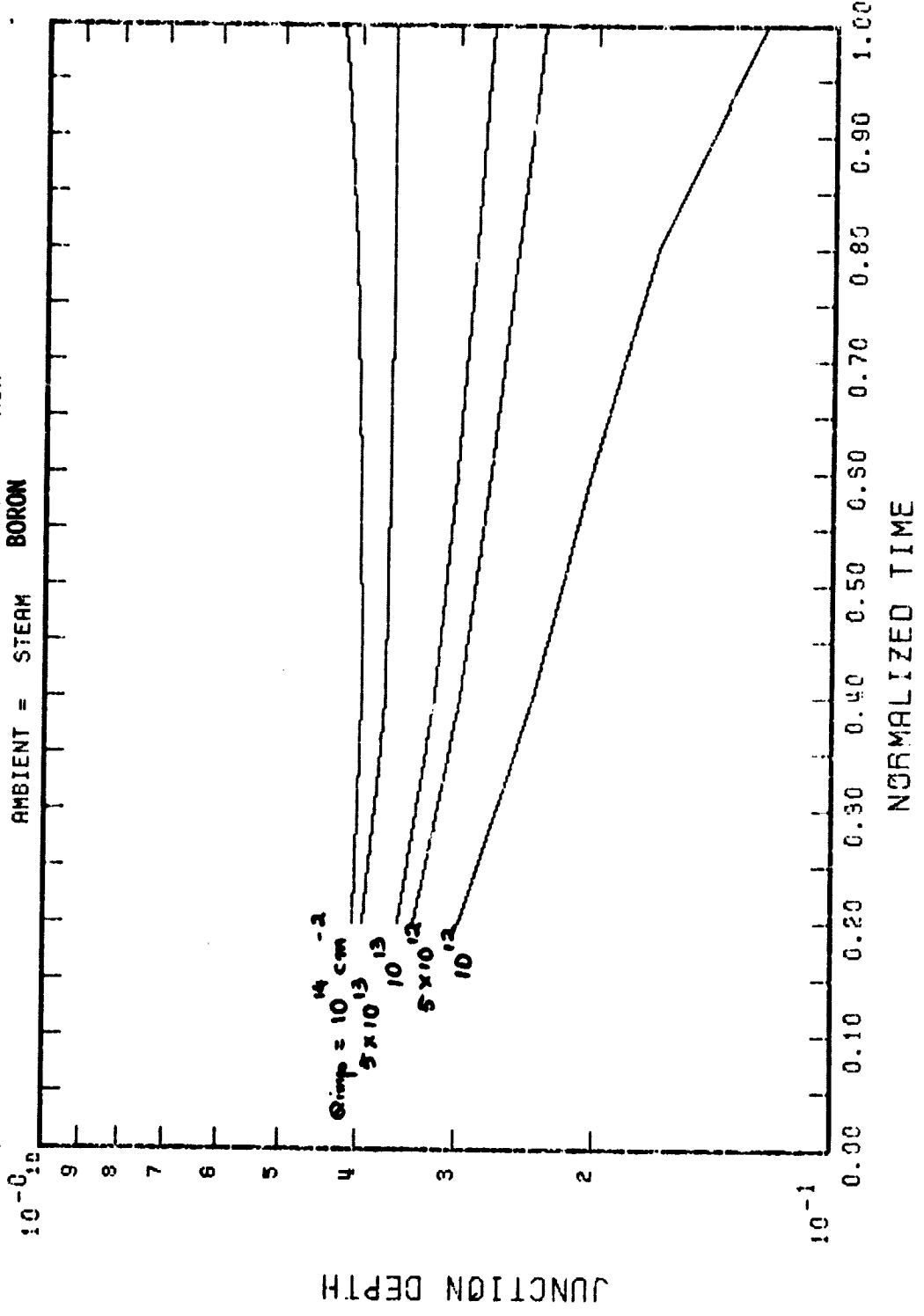


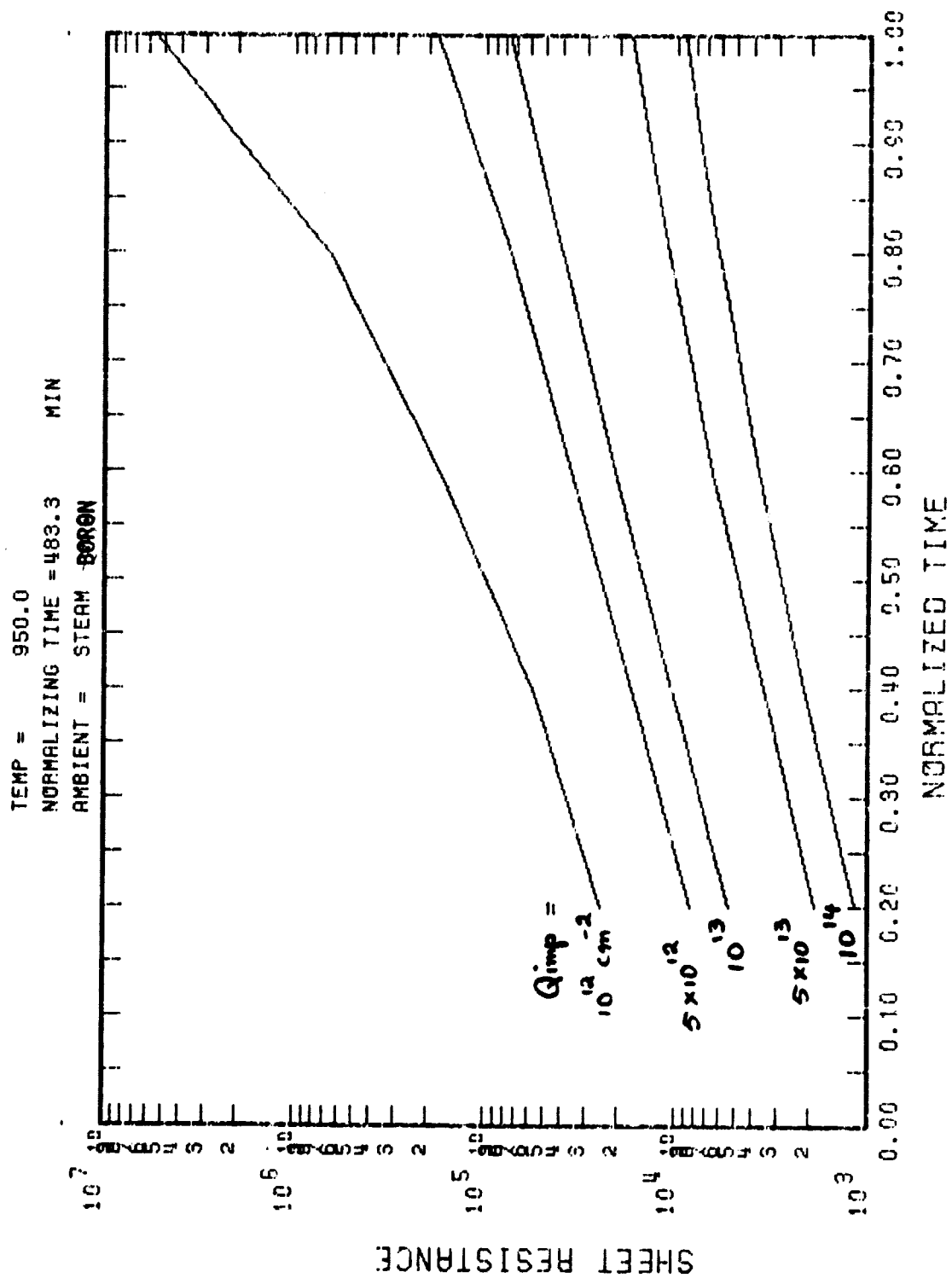
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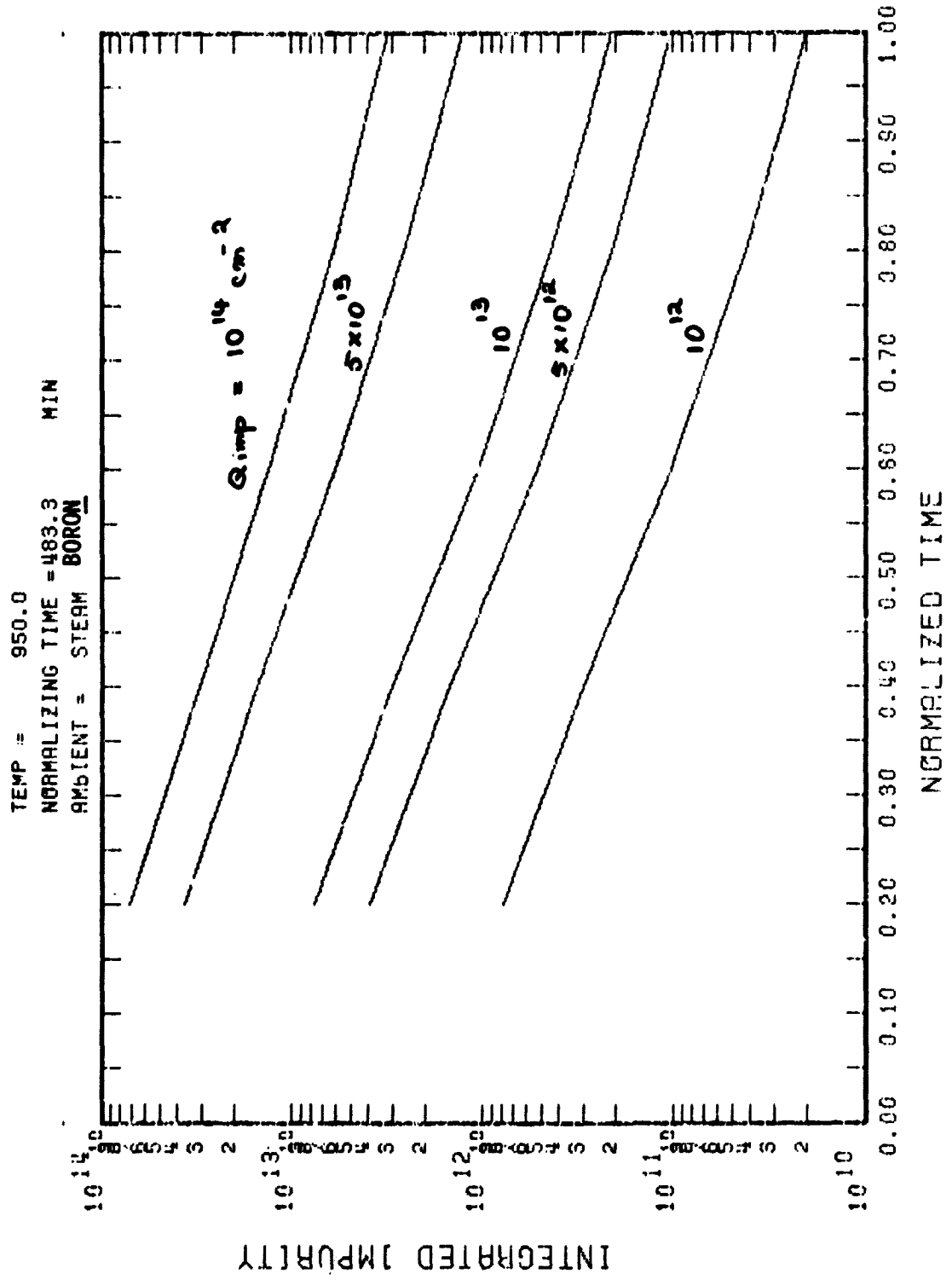
A 42



TEMP = 950.0 THICKNESS = 0.0 CM-4
NORMALIZING TIME = 483.3 MIN
AMBIENT = STEAM BORON

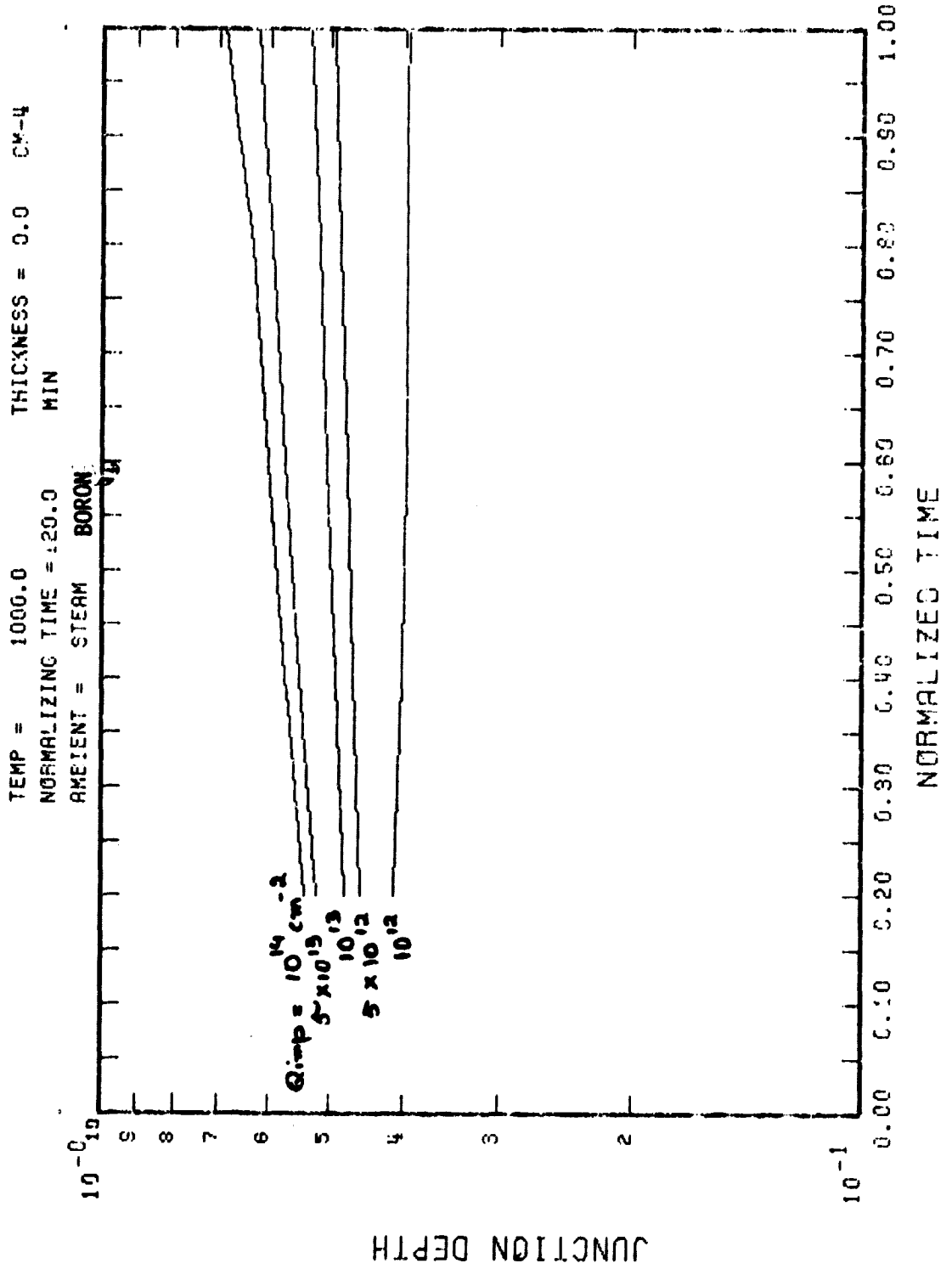


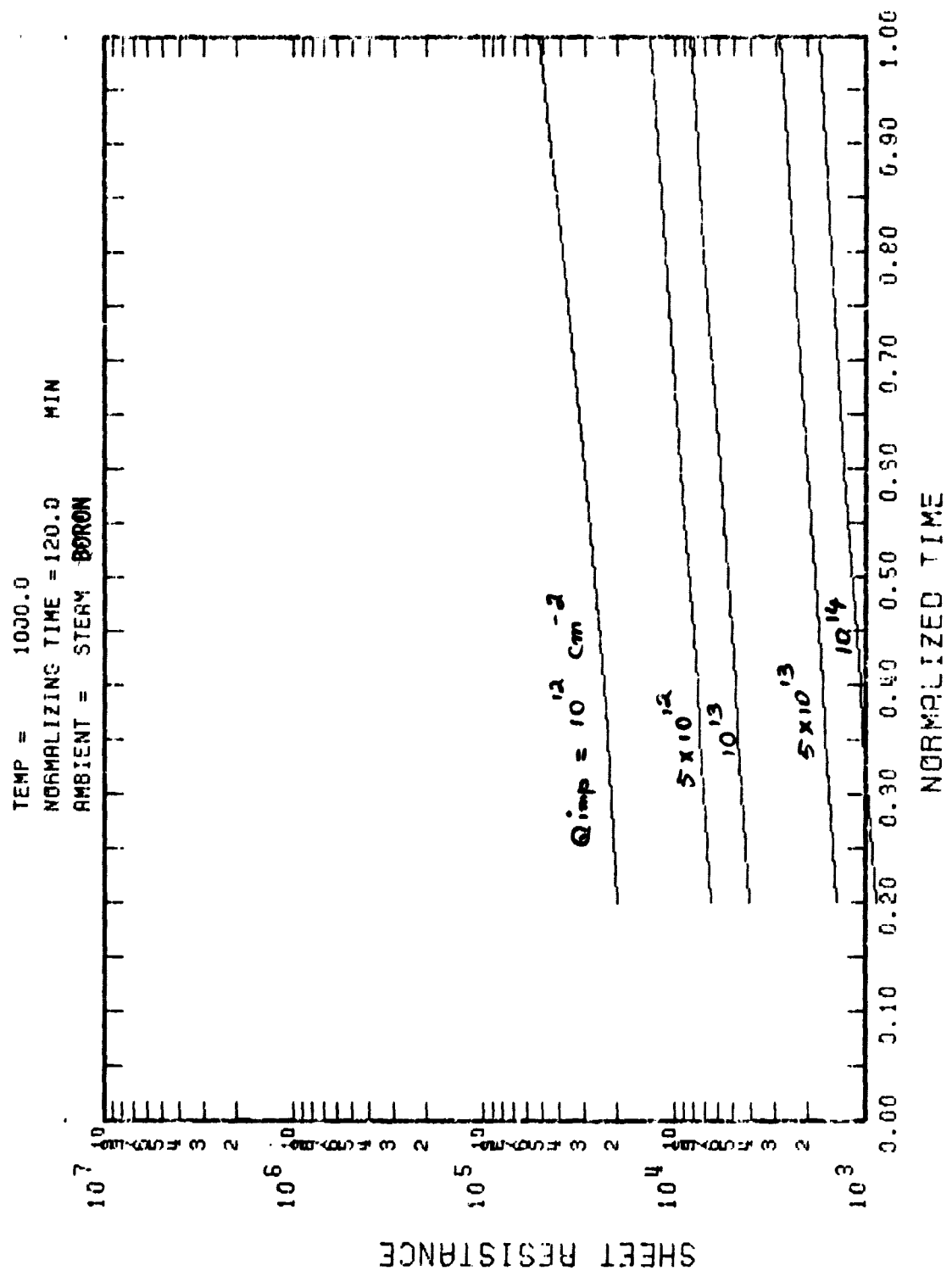


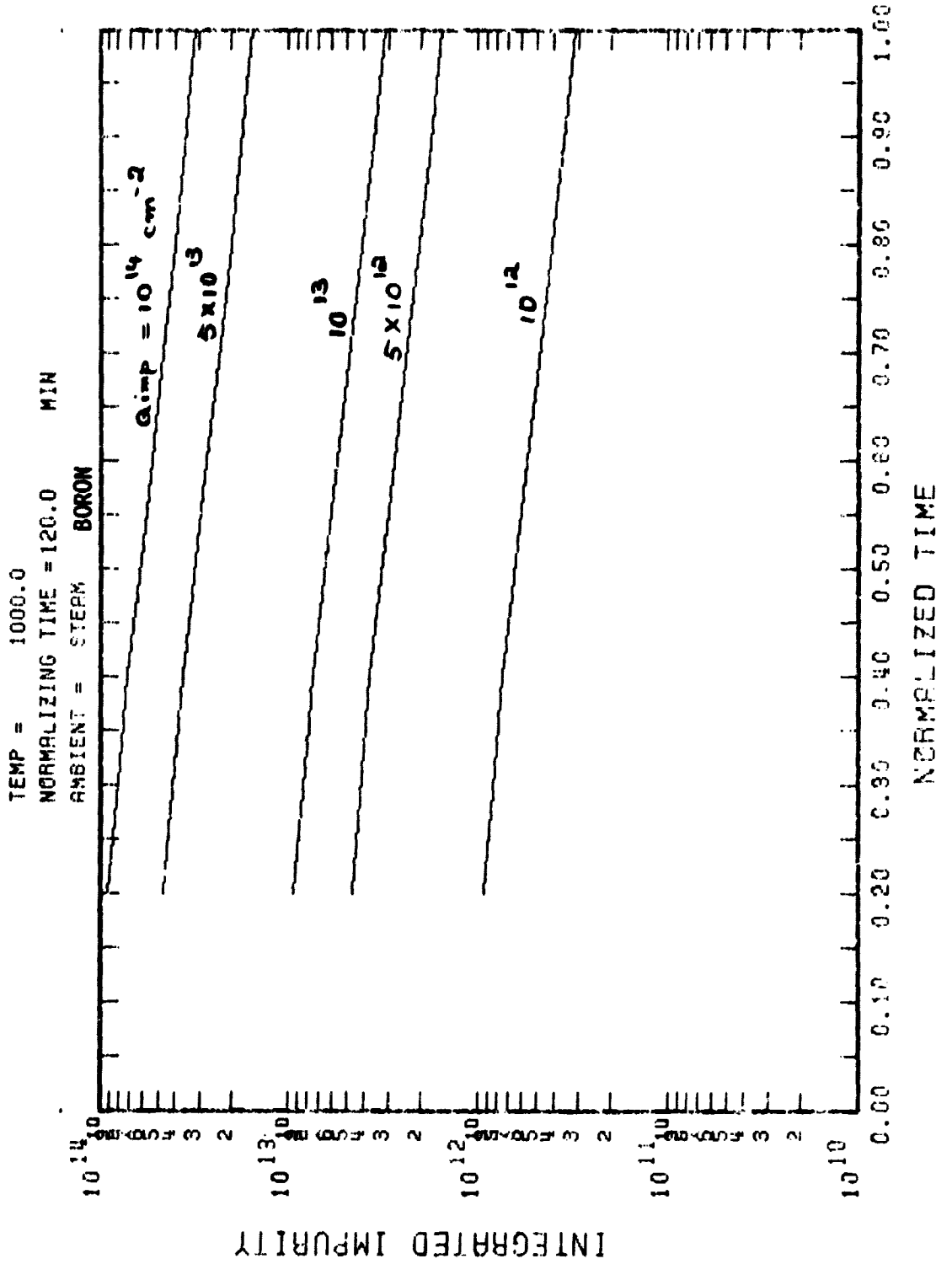


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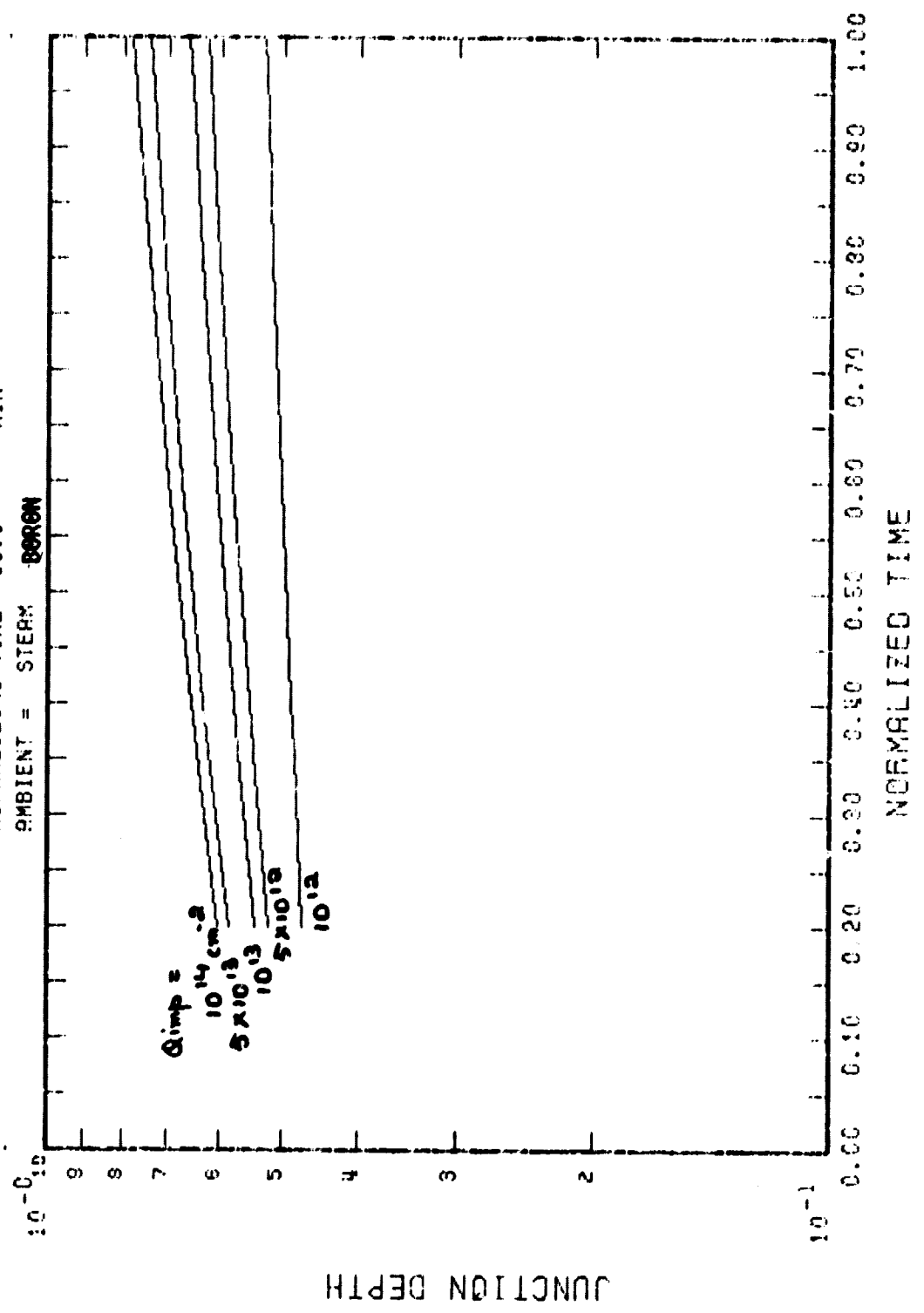
A 46



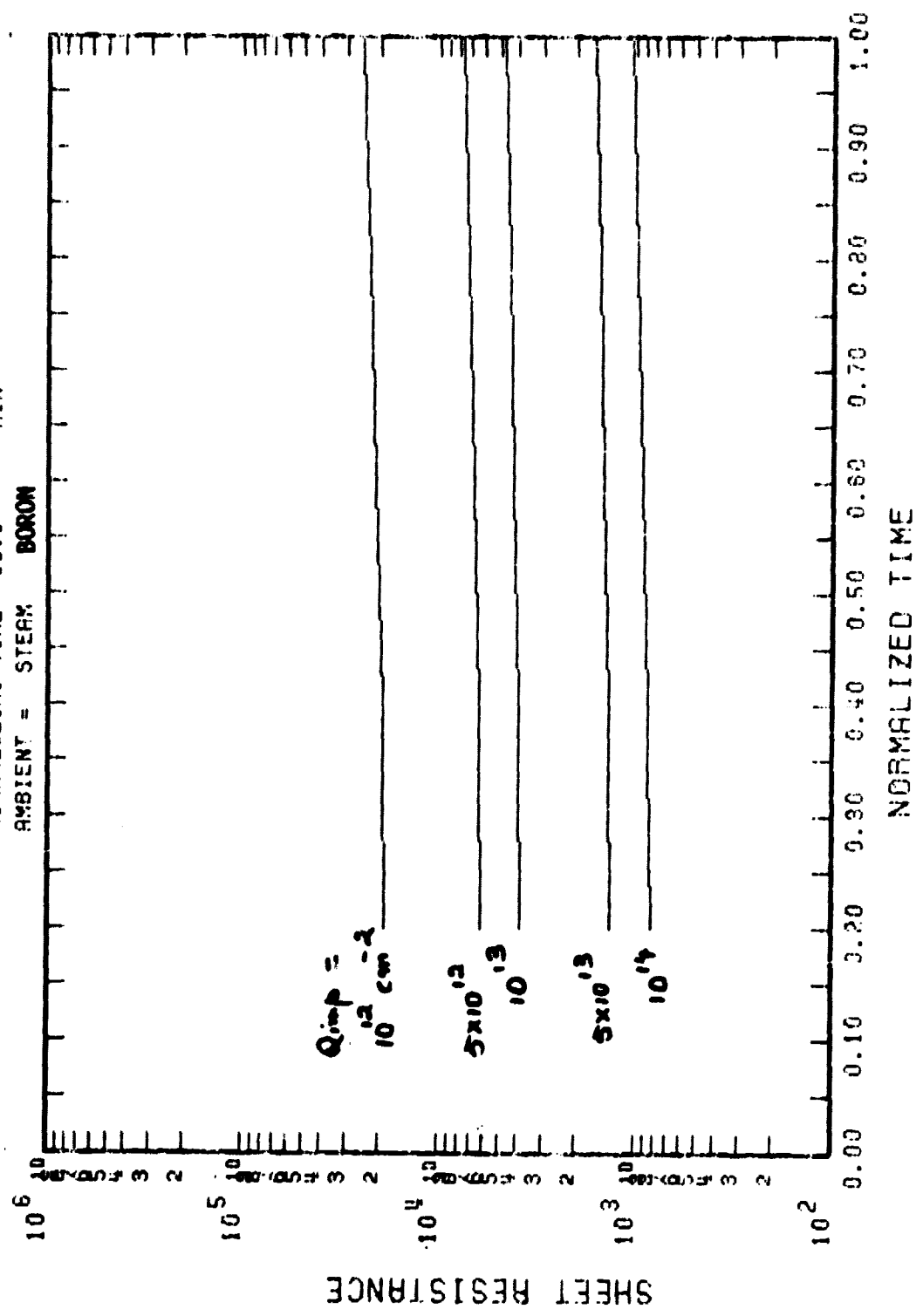




TEMP = 1050.0 THICKNESS = 0.0 CM-4
 NORMALIZING TIME = 30.0 MIN
 AMBIENT = STEAM BORON

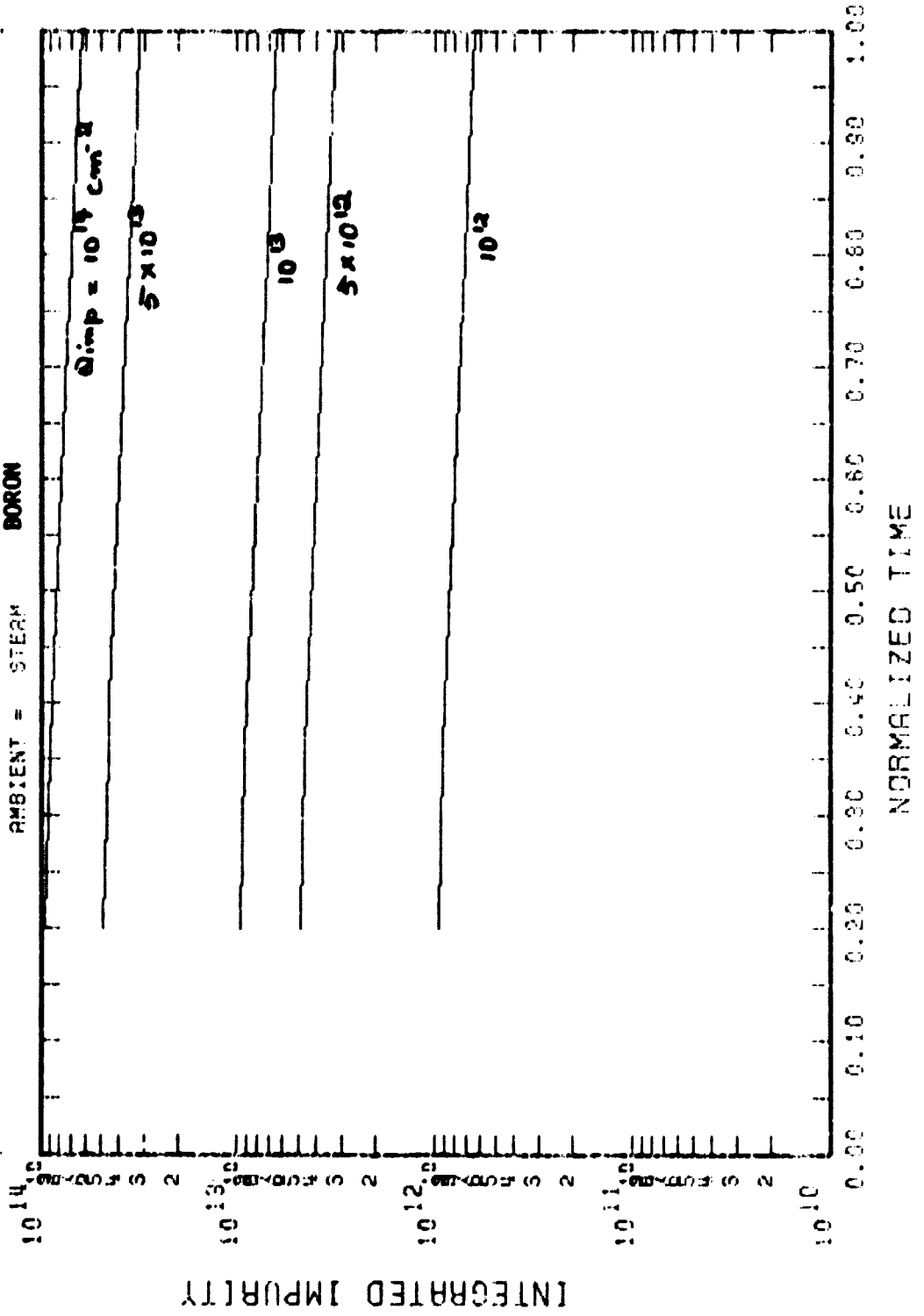


TEMP = 1050.0
 NORMALIZING TIME = 30.0 MIN
 AMBIENT = STEAK BORON



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TEMP = 1050.0
NORMALIZING TIME = 30.0 MIN
AMBIENT = STEAM BORON

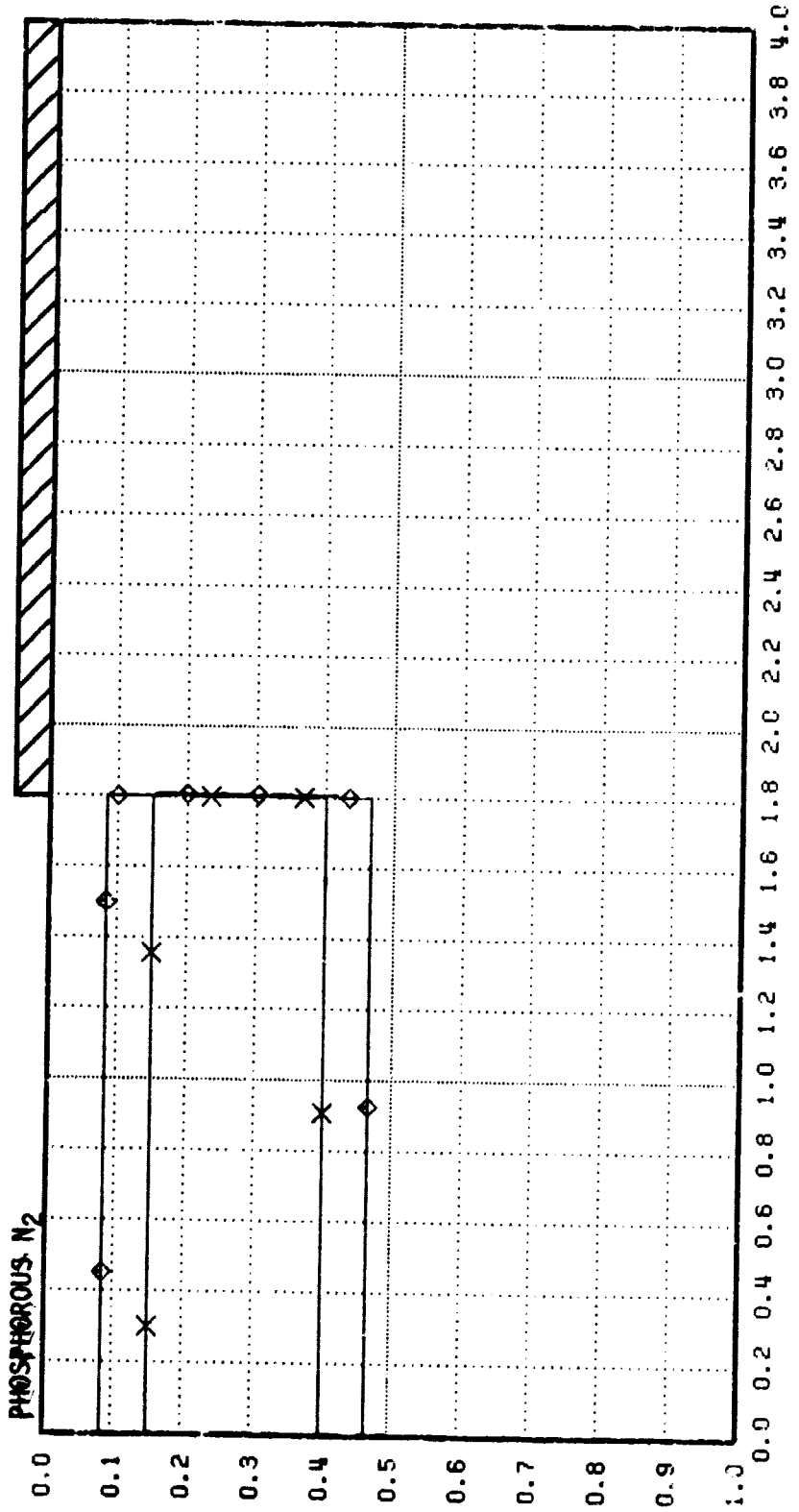


APPENDIX

PHOSPHORUS DATA

λ^2 = 0.0308
TEMPERATURE = 1000.
TIME STEP = 0
TIME = 0.00

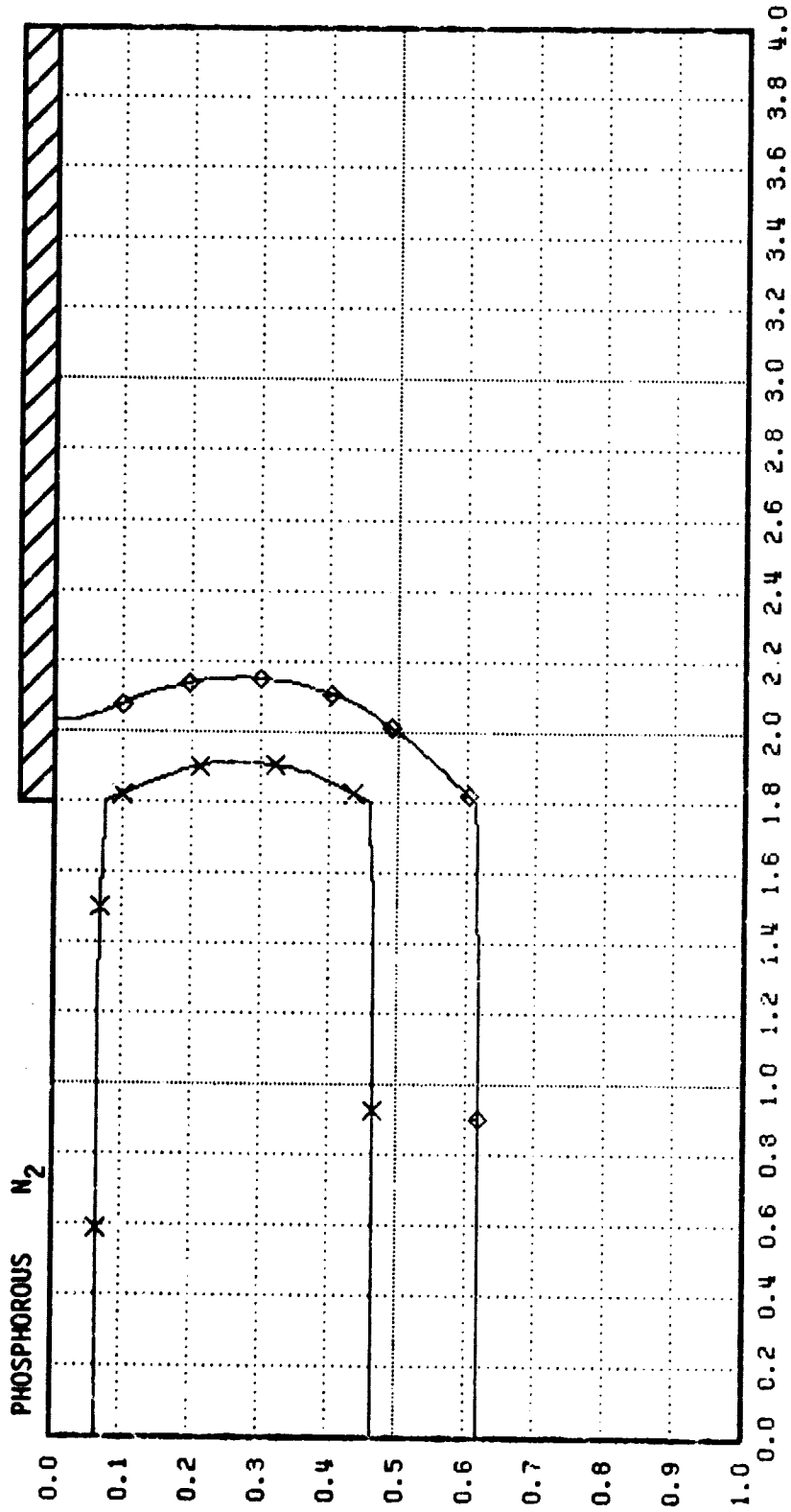
□ - 1.0E20
⊙ - 1.0E19
▲ - 1.0E18
+ - 1.0E17
x - 1.0E16
◇ - 1.0E15



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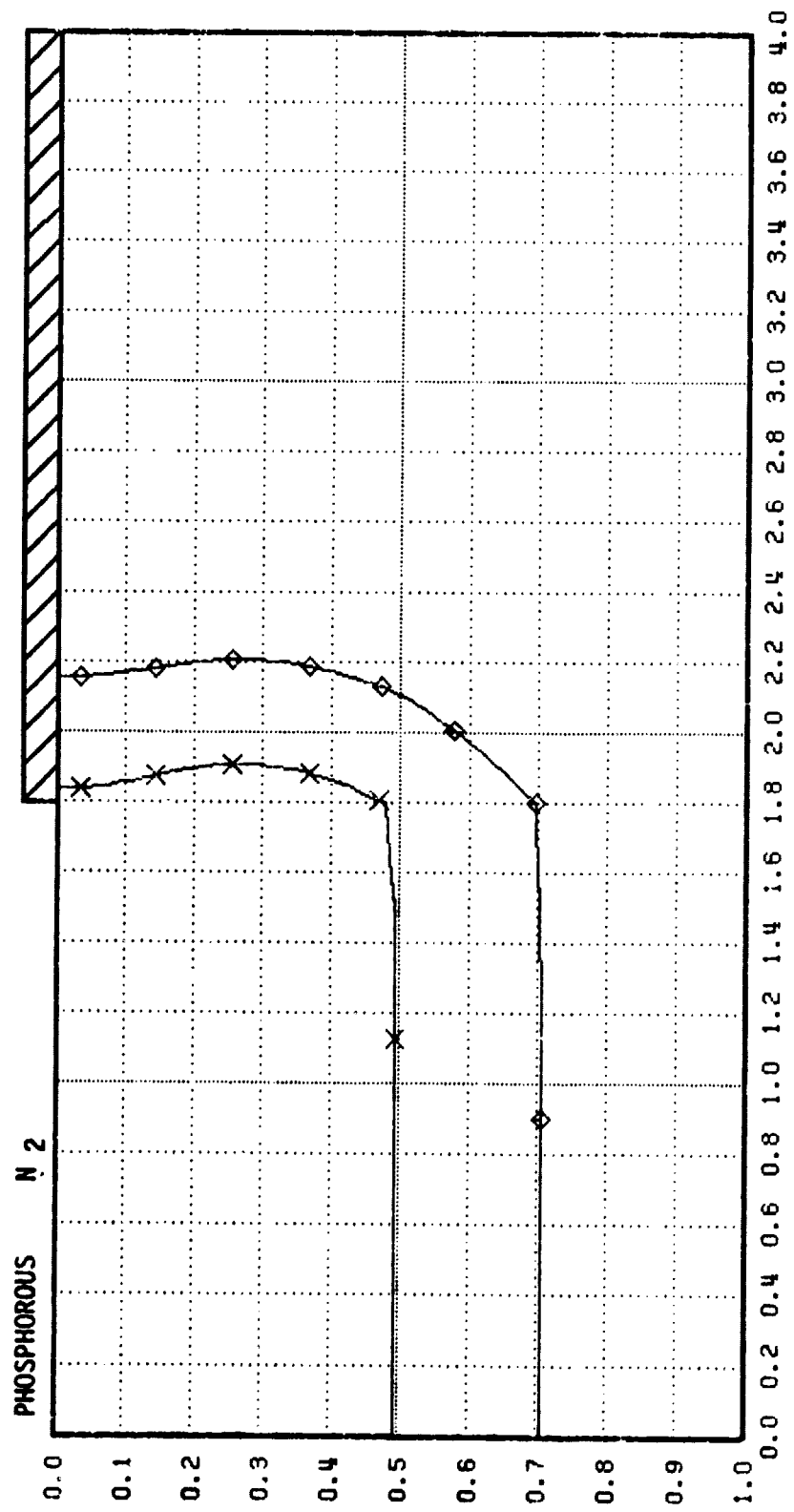
λ^2 = 0.0308
 TEMPERATURE = 1000.
 TIME STEP = 10
 TIME = 0.20

□ - 1.0E20
 ○ - 1.0E19
 ▲ - 1.0E18
 + - 1.0E17
 × - 1.0E16
 ◇ - 1.0E15



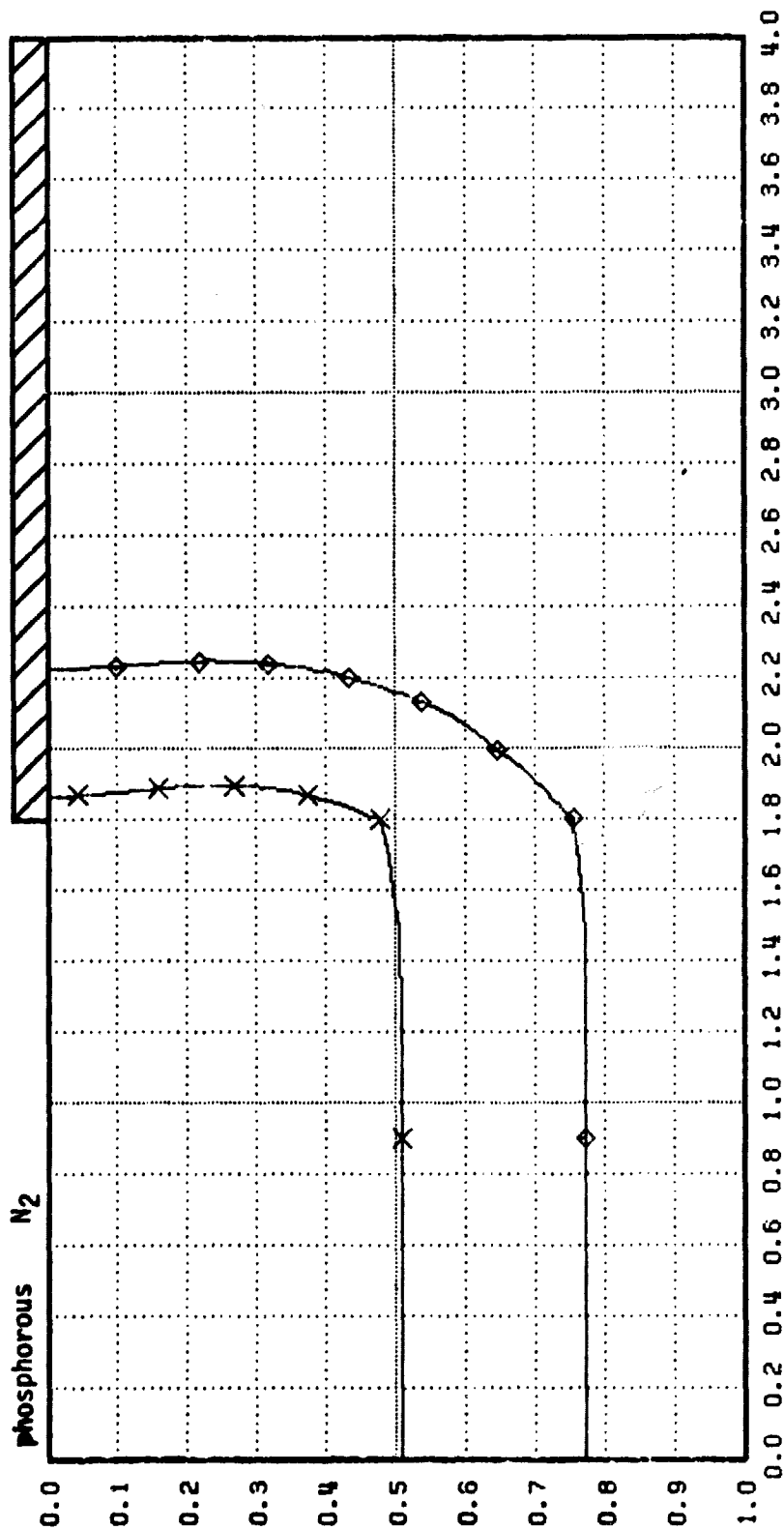
λ^2 = 0.0308
 TEMPERATURE = 1000.
 TIME STEP = 20
 TIME = 0.40

- - 1.0E20
- - 1.0E19
- △ - 1.0E18
- + - 1.0E17
- x - 1.0E16
- ◇ - 1.0E15



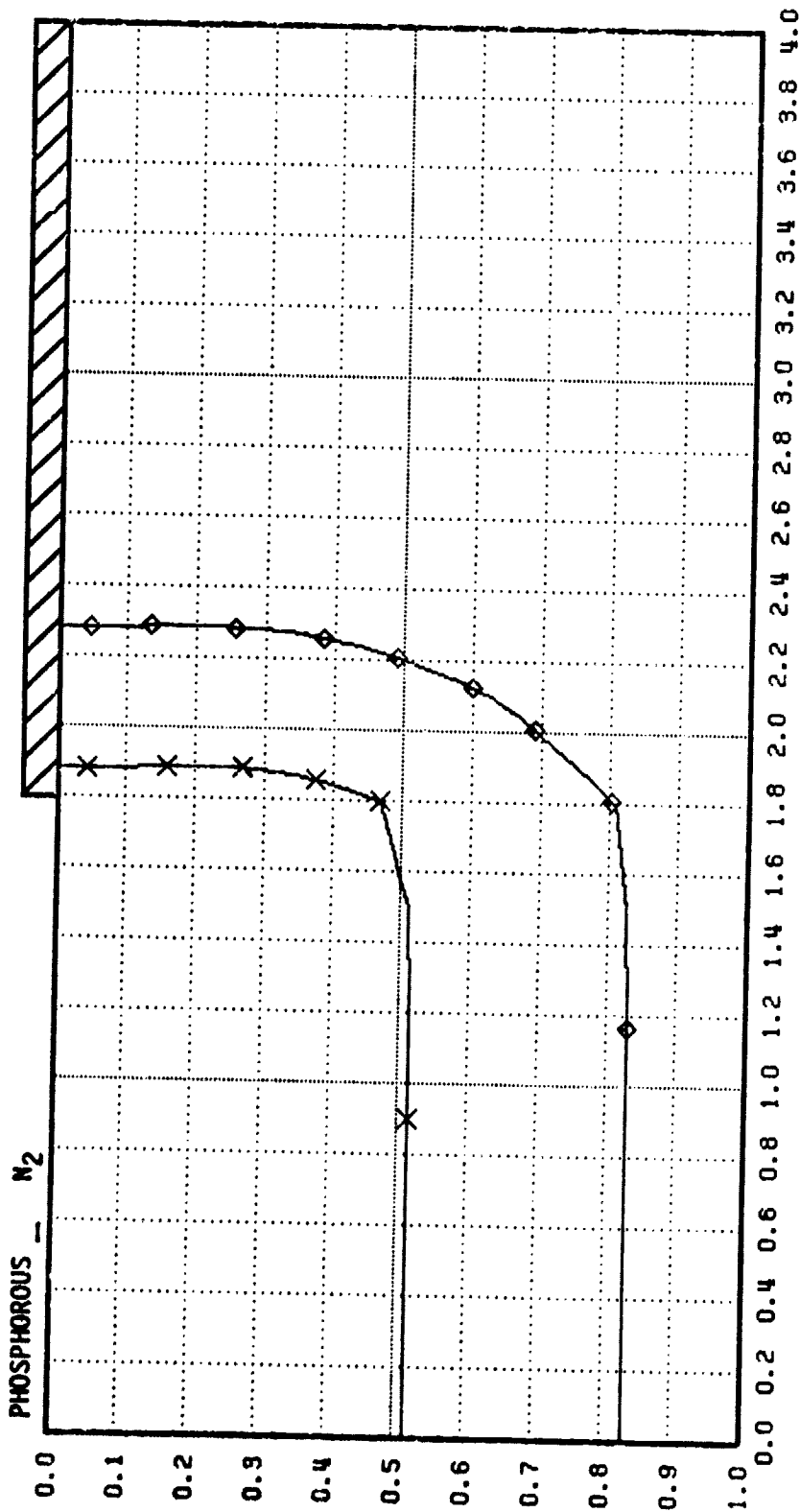
λ^2
 TEMPERATURE = 0.0308
 TIME STEP = 1000.
 TIME = 30
 = 0.60

□ - 1.0E20
 ○ - 1.0E19
 △ - 1.0E18
 + - 1.0E17
 × - 1.0E16
 ◇ - 1.0E15



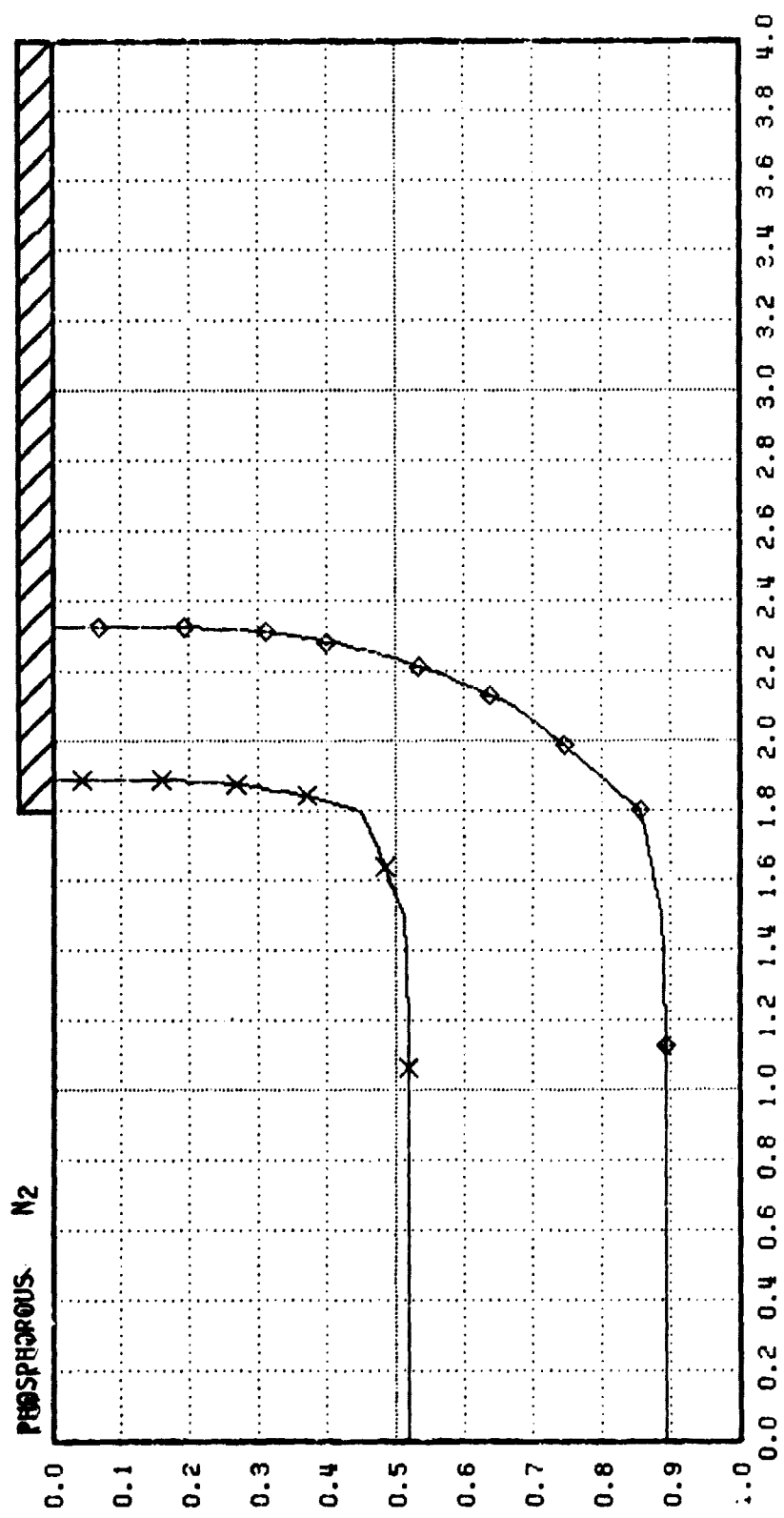
λ^2 = 0.0308
 TEMPERATURE = 1000.
 TIME STEP = 40
 TIME = 0.80

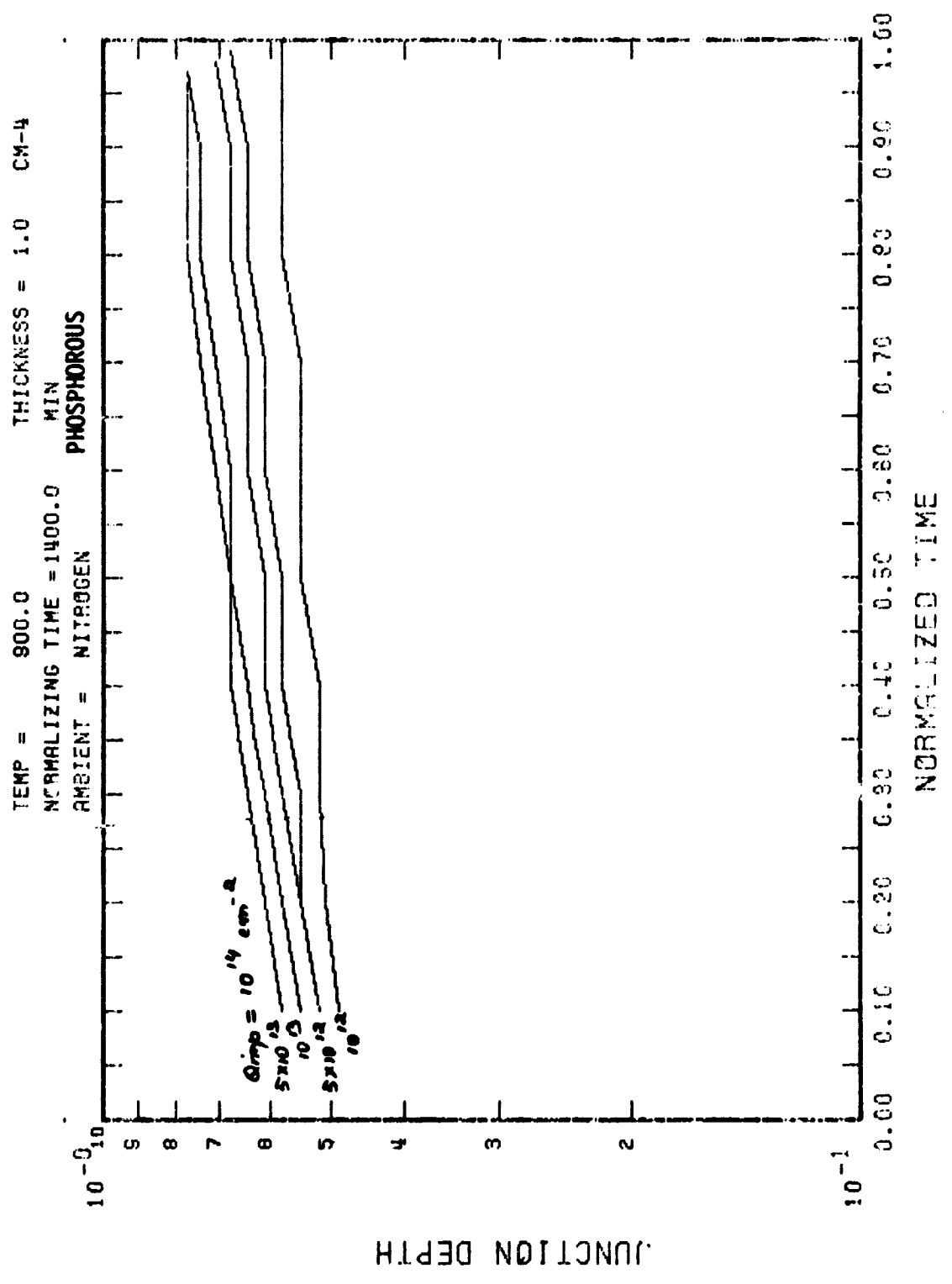
□ - 1.0E20
 ○ - 1.0E19
 △ - 1.0E18
 + - 1.0E17
 × - 1.0E16
 ◇ - 1.0E15



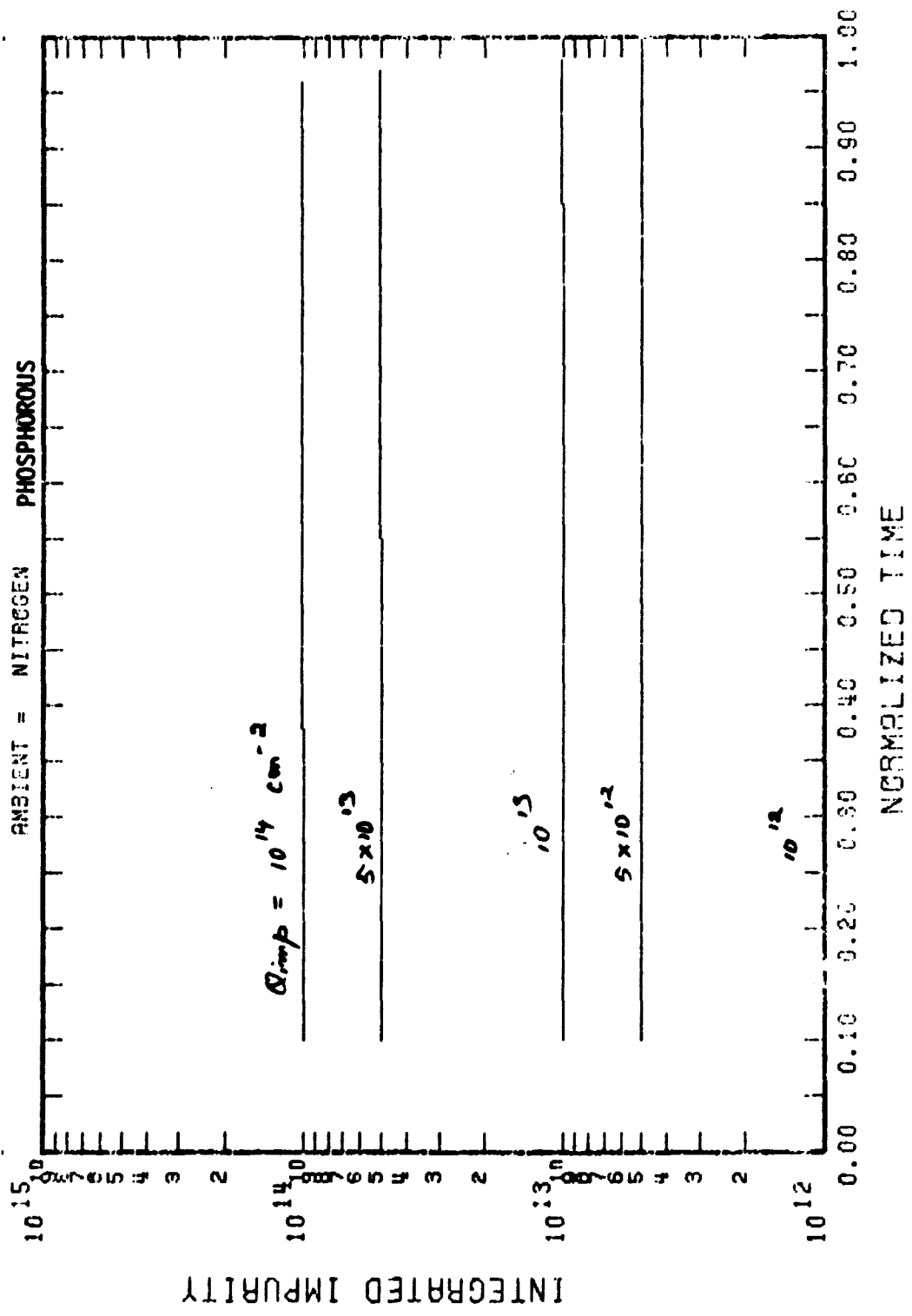
λ^2 = 0.0308
 TEMPERATURE = 1000.
 TIME STEP = 50
 TIME = 1.00

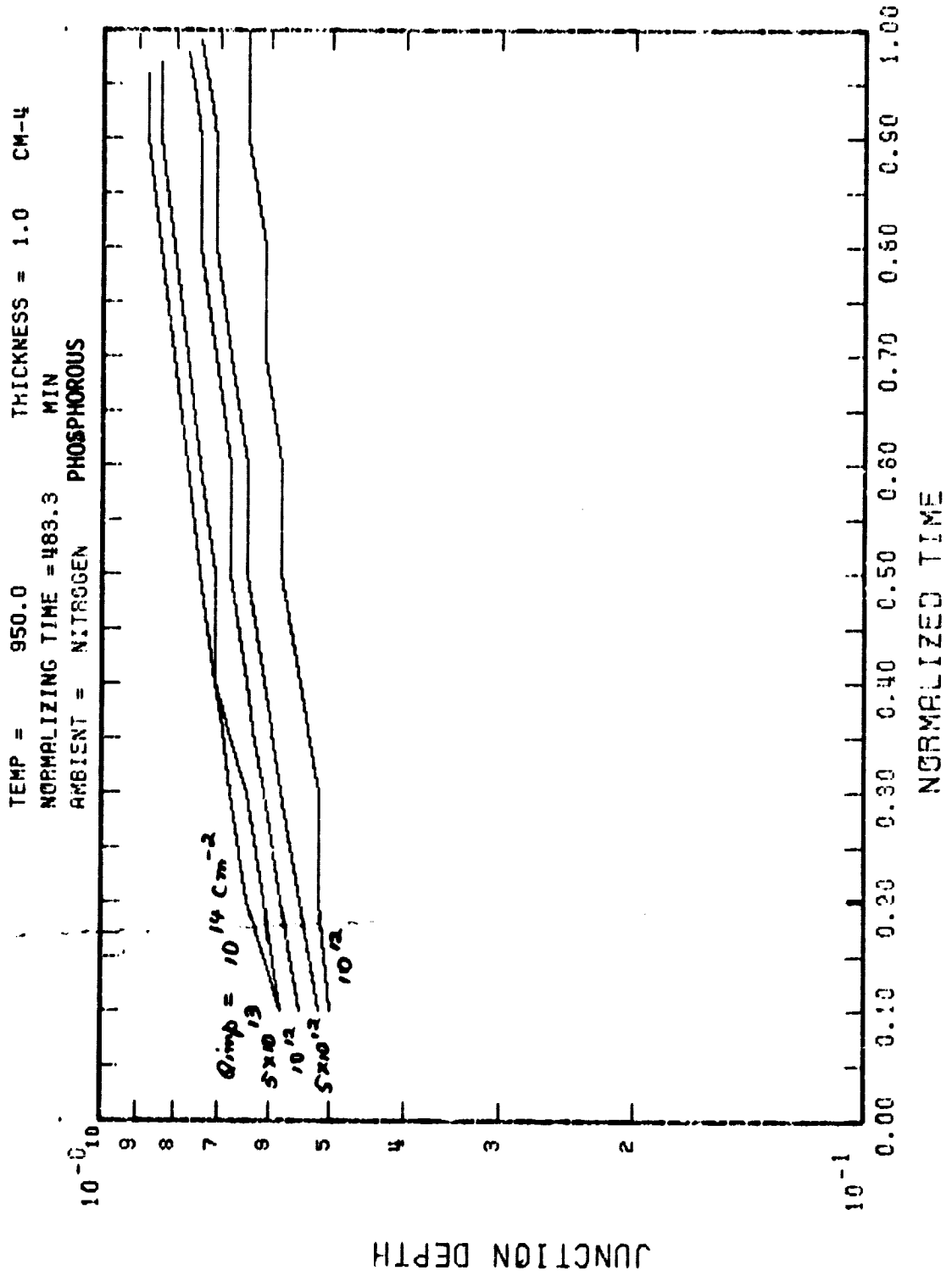
□ - 1.0E20
 ○ - 1.0E19
 ▲ - 1.0E18
 + - 1.0E17
 × - 1.0E16
 ◇ - 1.0E15





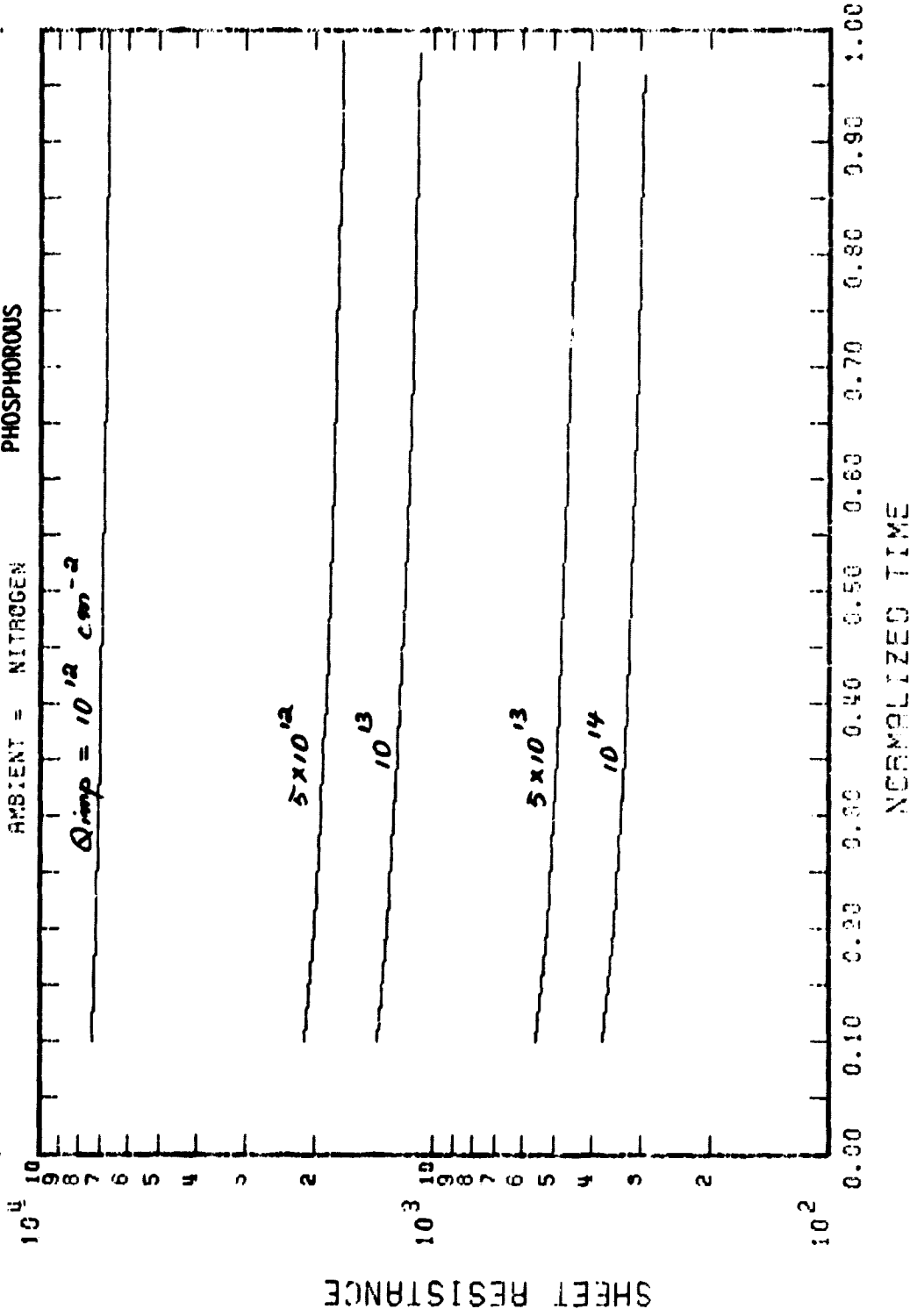
TEMP = 900.0
NORMALIZING TIME = 1400.0 MIN
AMBIENT = NITROGEN PHOSPHOROUS

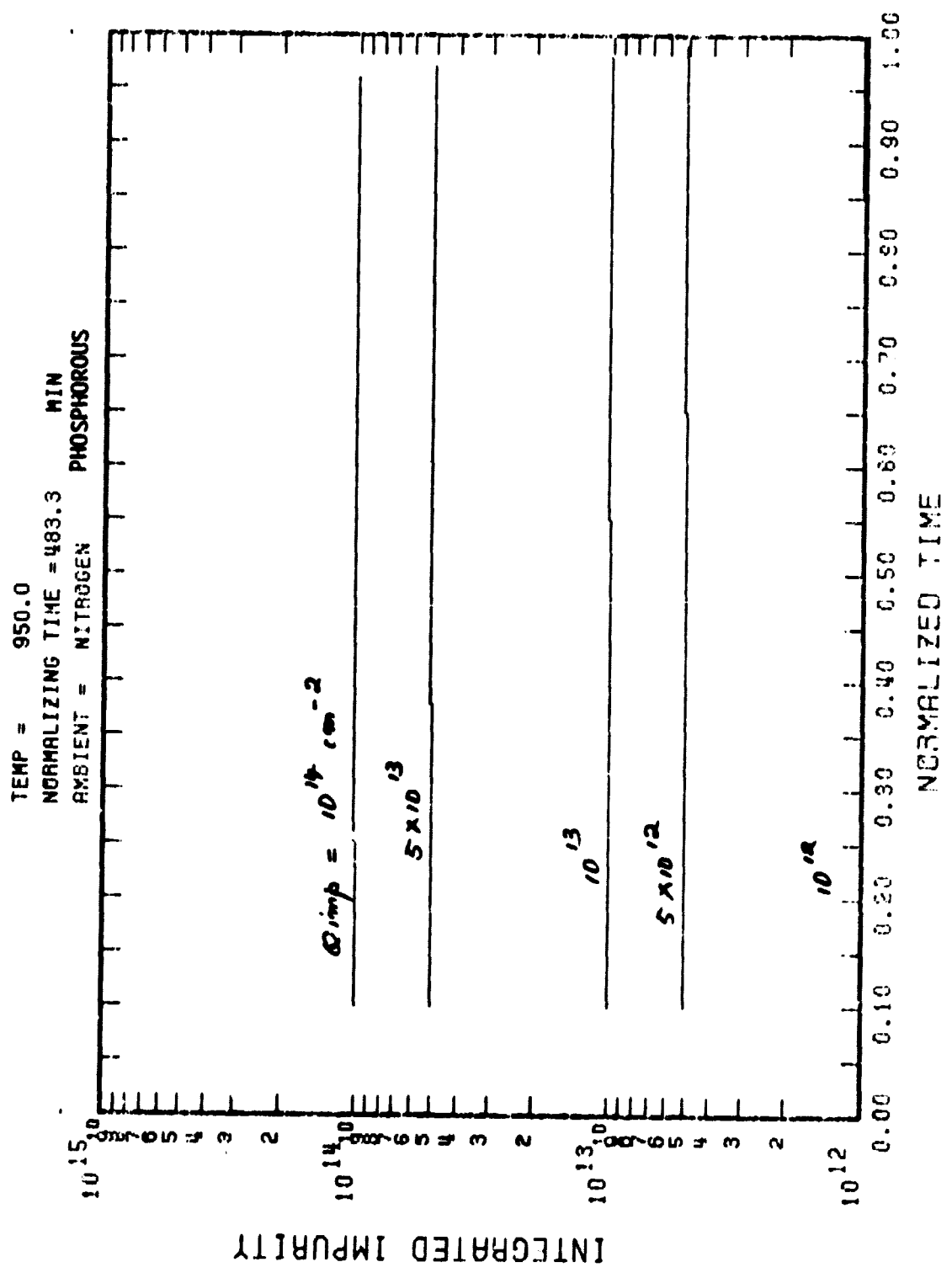




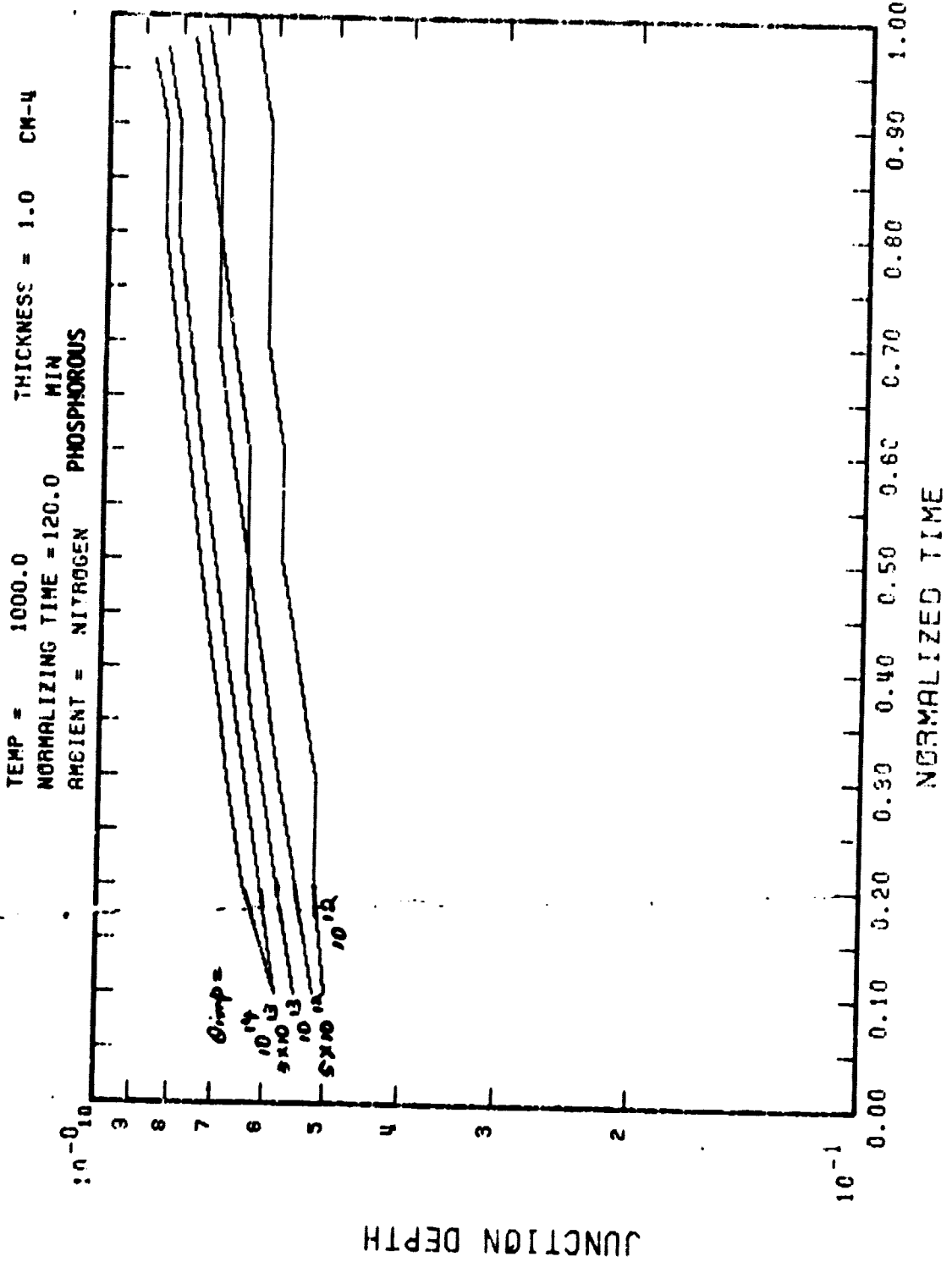
TEMP = 950.0
NORMALIZING TIME = 483.3 MIN
AMBIENT = NITROGEN
PHOSPHOROUS

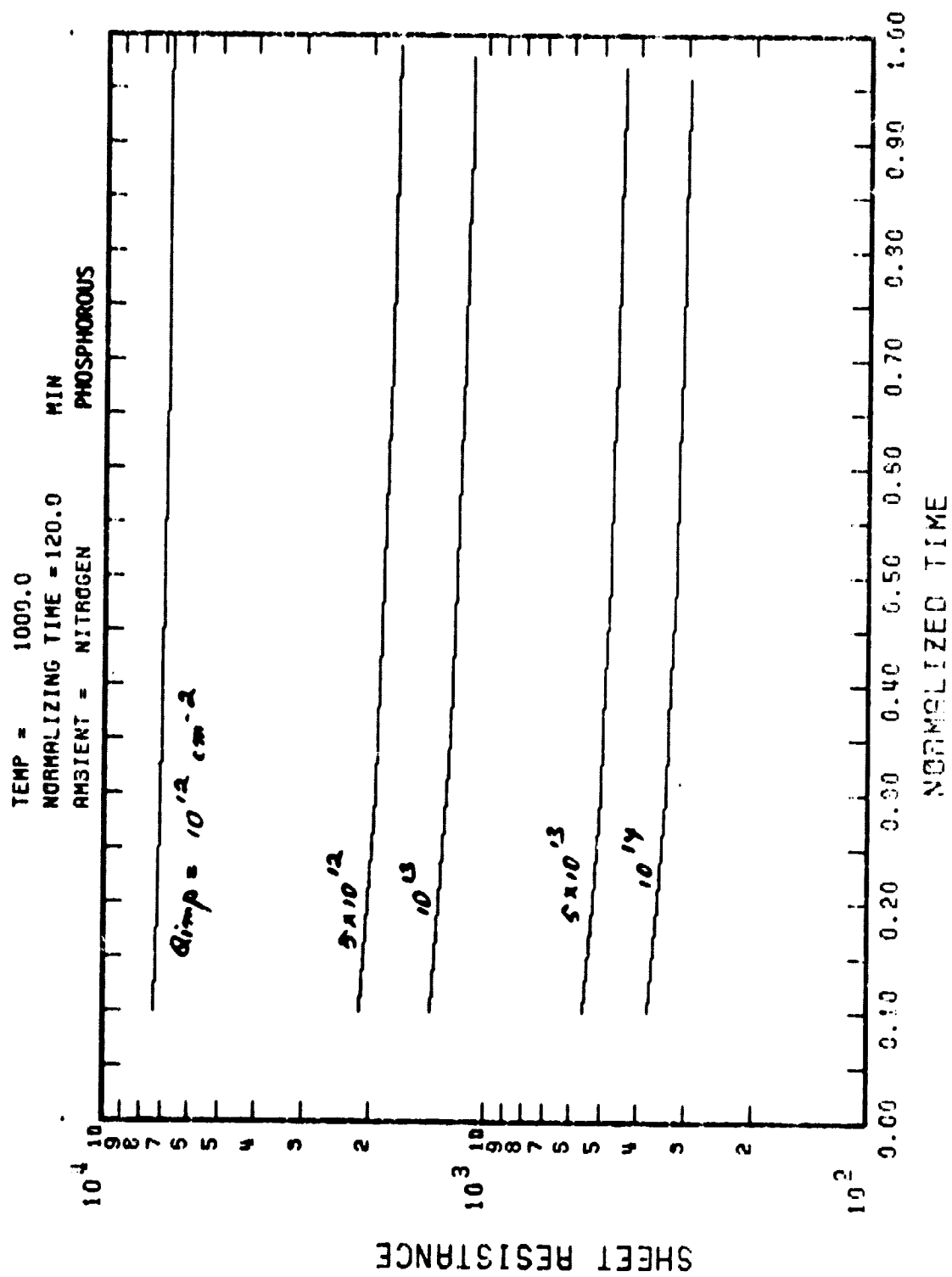
$$\Delta_{imp} = 10^{12} \text{ cm}^{-2}$$

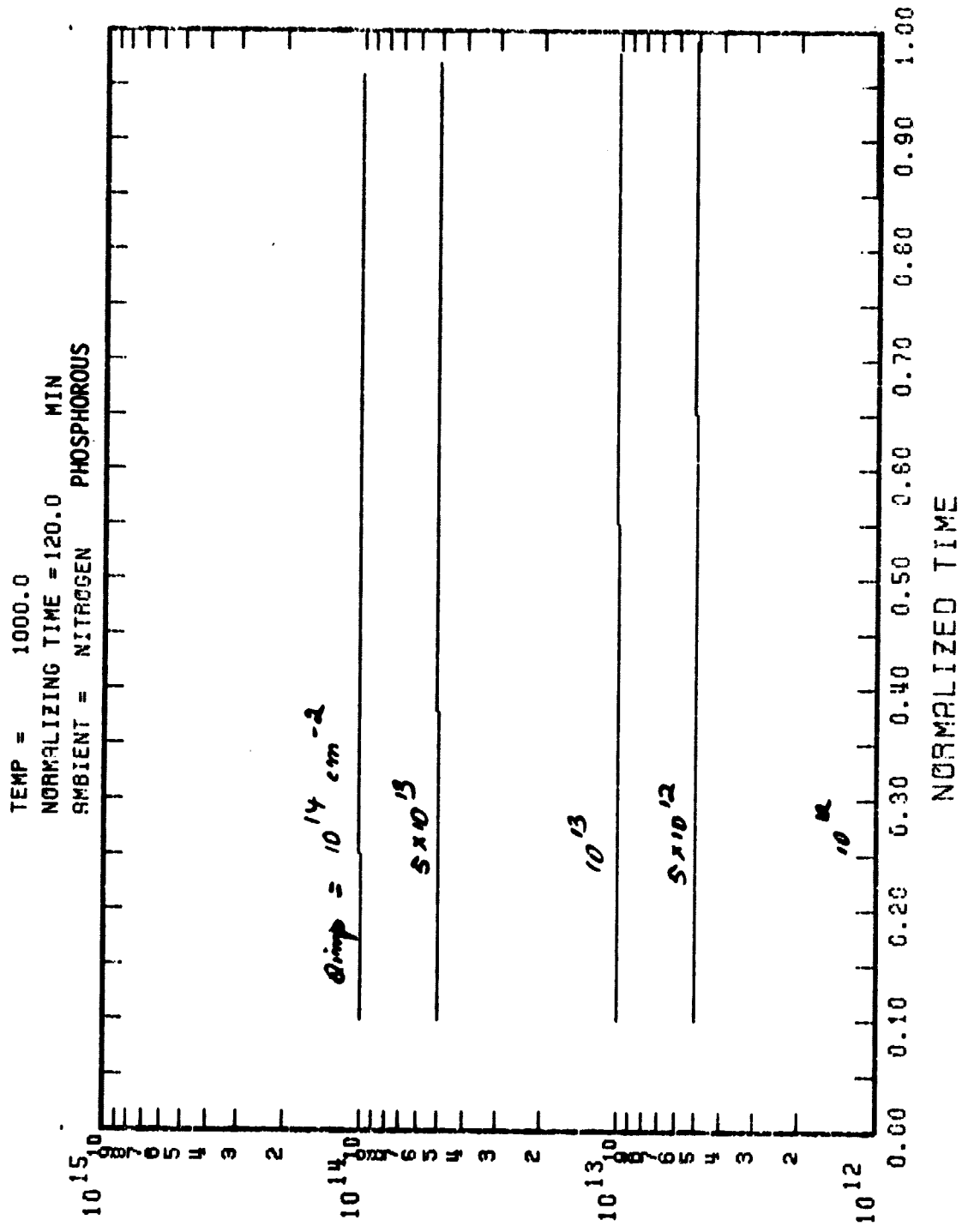




C. 2







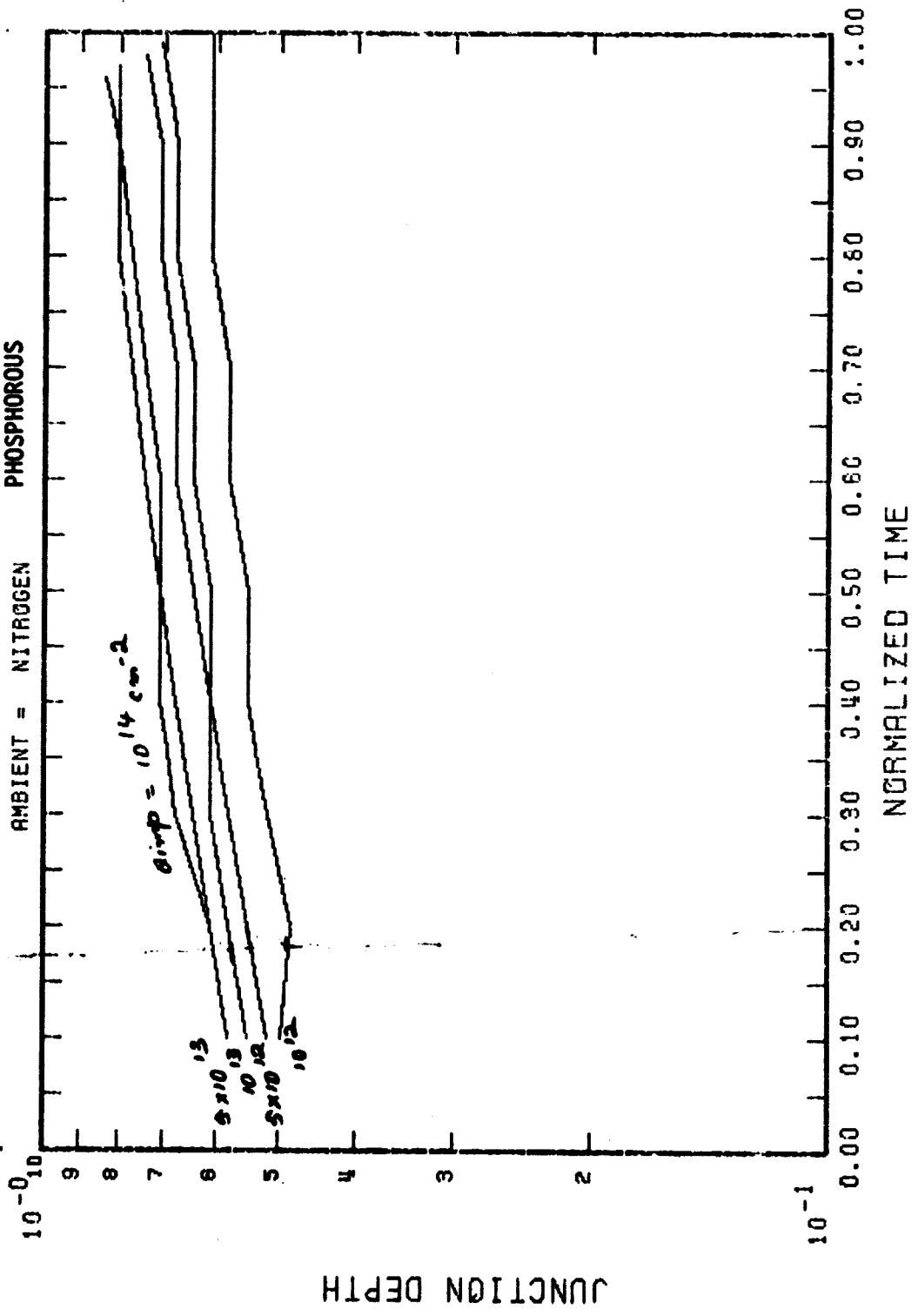
INTEGRATED IMPURITY

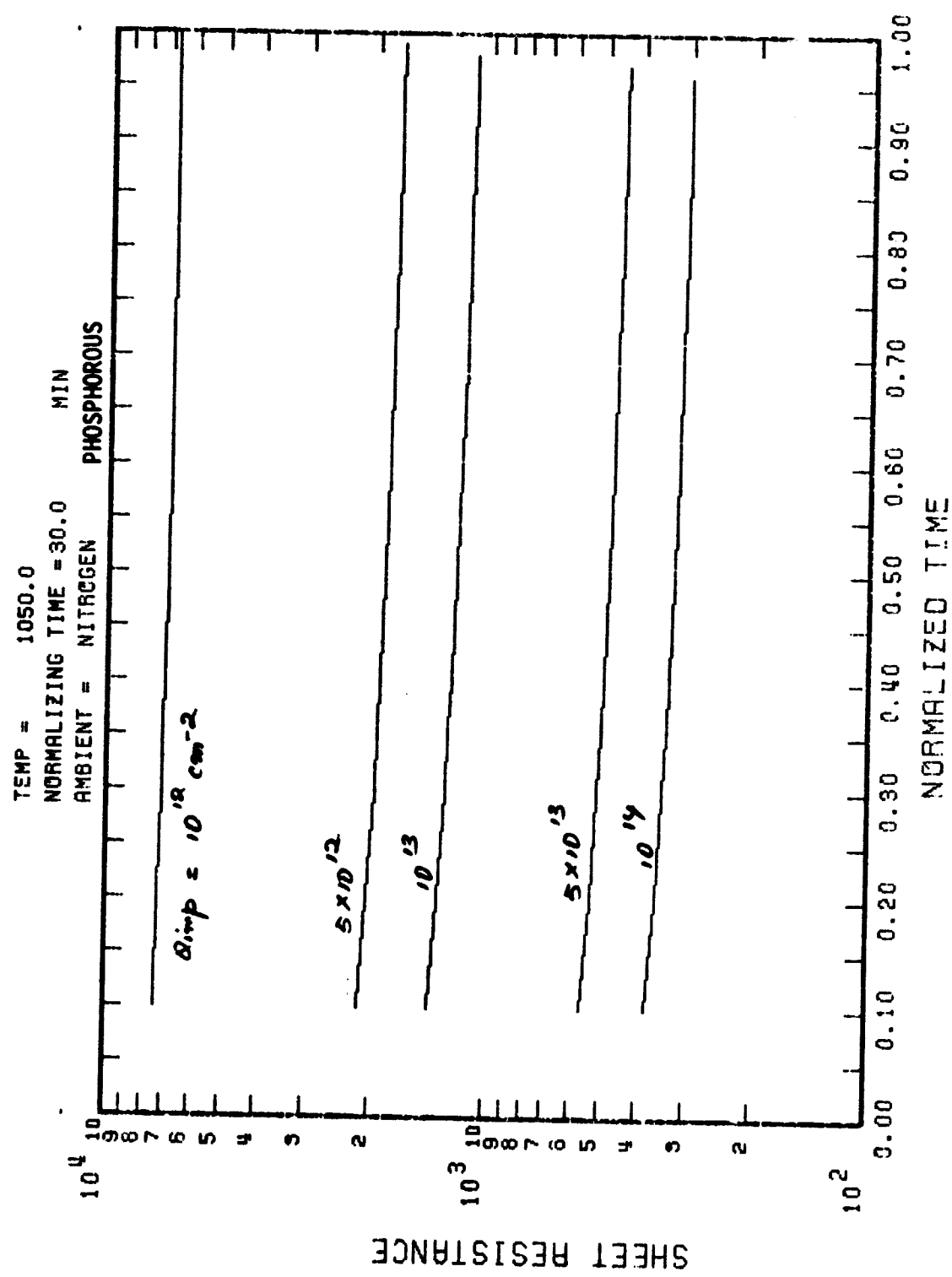
NORMALIZED TIME

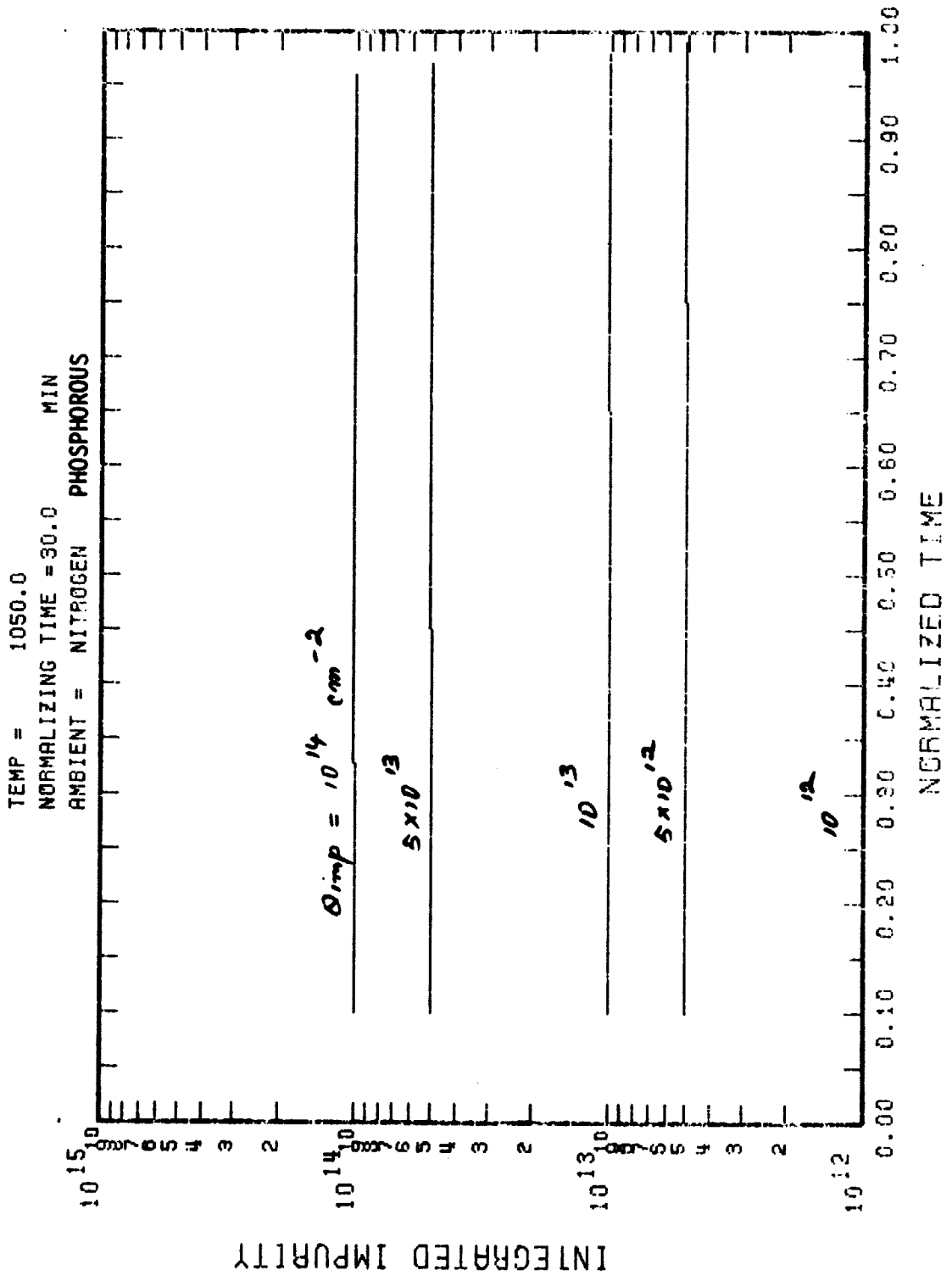
C-2

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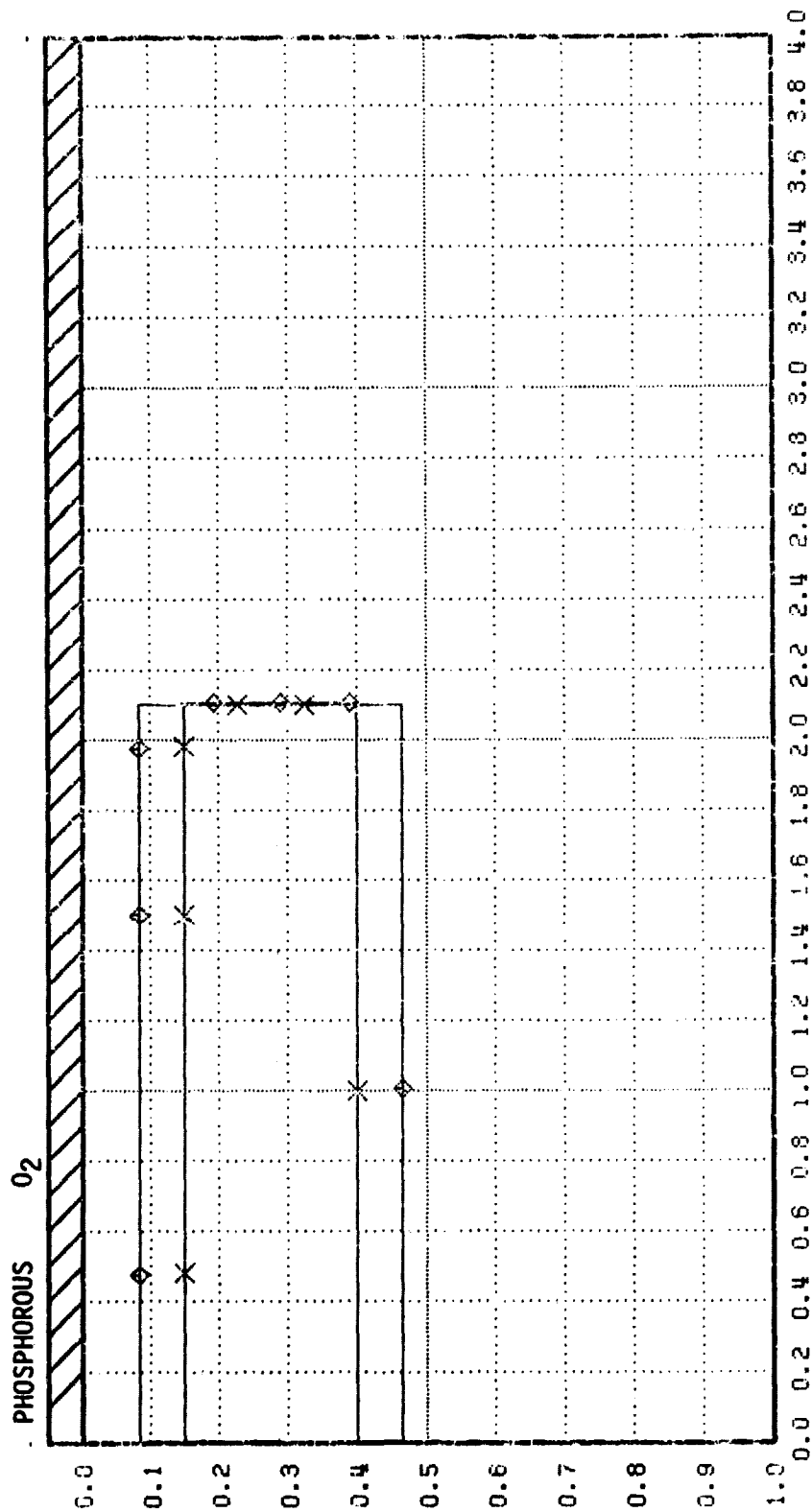
TEMP = 1050.0 THICKNESS = 1.0 CM-4
NORMALIZING TIME = 30.0 MIN
AMBIENT = NITROGEN PHOSPHOROUS



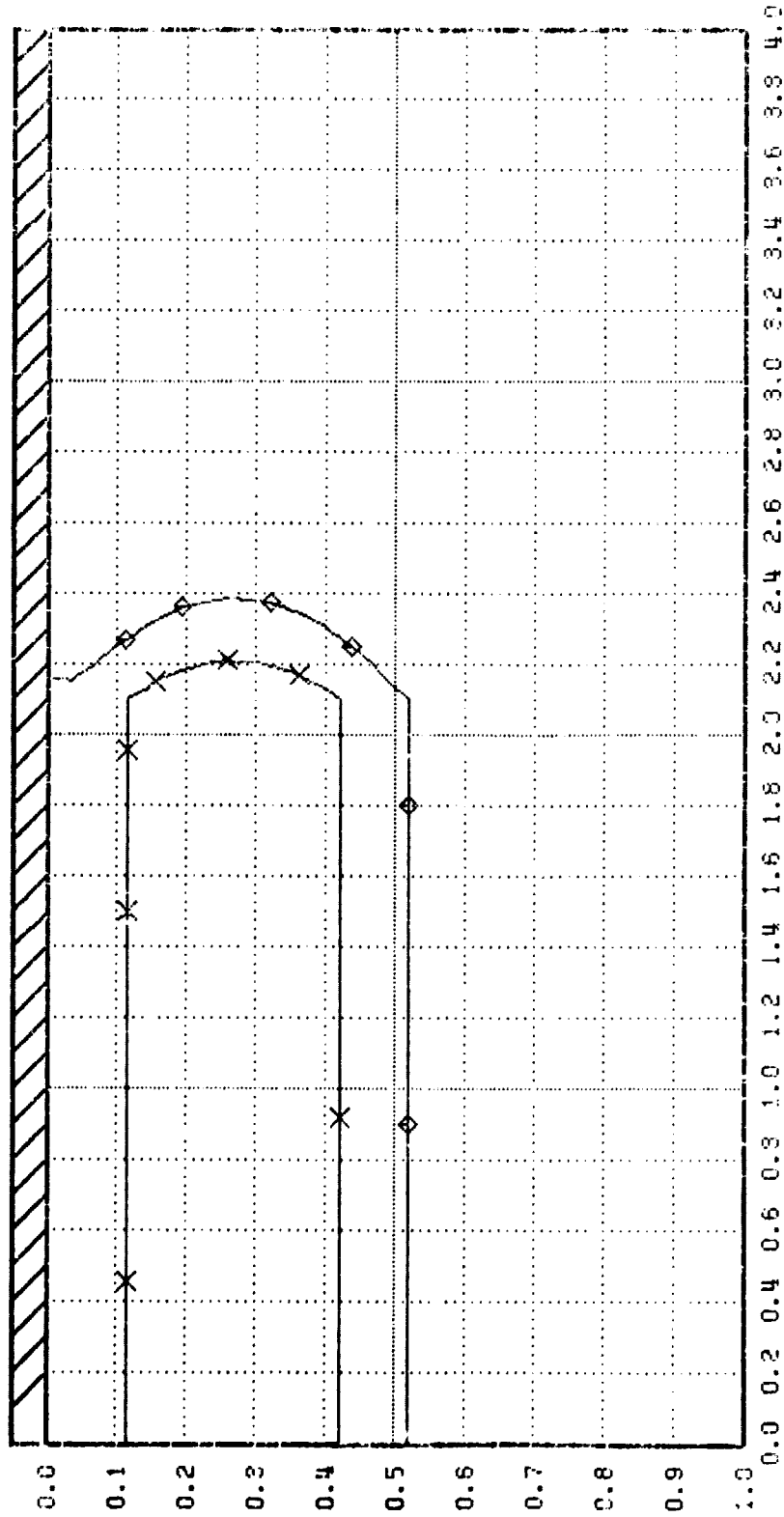




λ^2
 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 0
 = 0.00
 - 1.0E20
 - 1.0E19
 - 1.0E18
 - 1.0E17
 - 1.0E16
 - 1.0E15

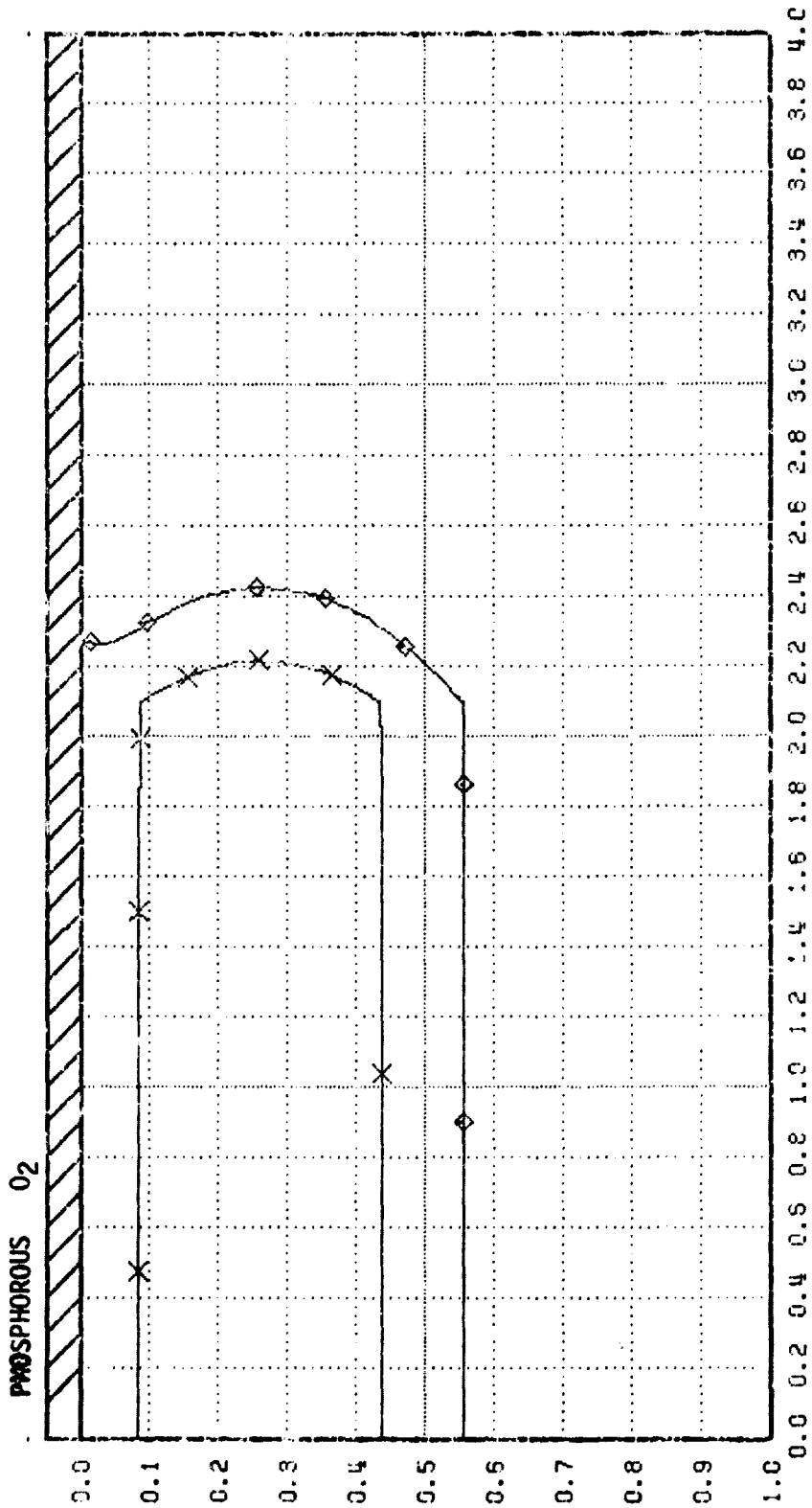


λ^2 = 0.0000
 TEMPERATURE = 1000.
 TIME STEP = 20
 TIME = 1440.00
 PHOSPHOROUS O₂



χ^2 = 0.0000
 TEMPERATURE = 1000.
 TIME STEP = 40
 TIME = 2880.00

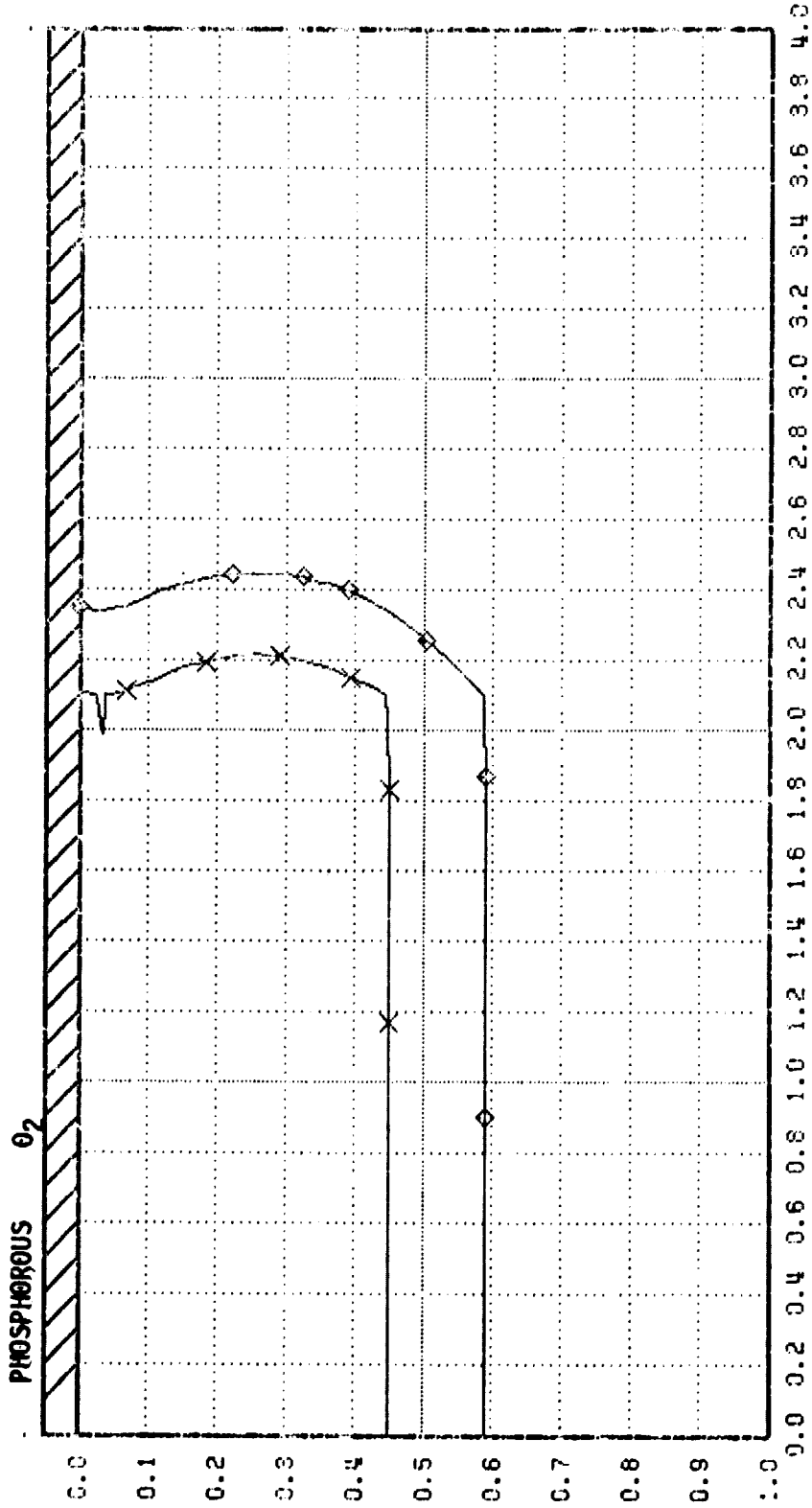
E - 1.0E20
 O - 1.0E19
 A - 1.0E18
 + - 1.0E17
 X - 1.0E16
 D - 1.0E15



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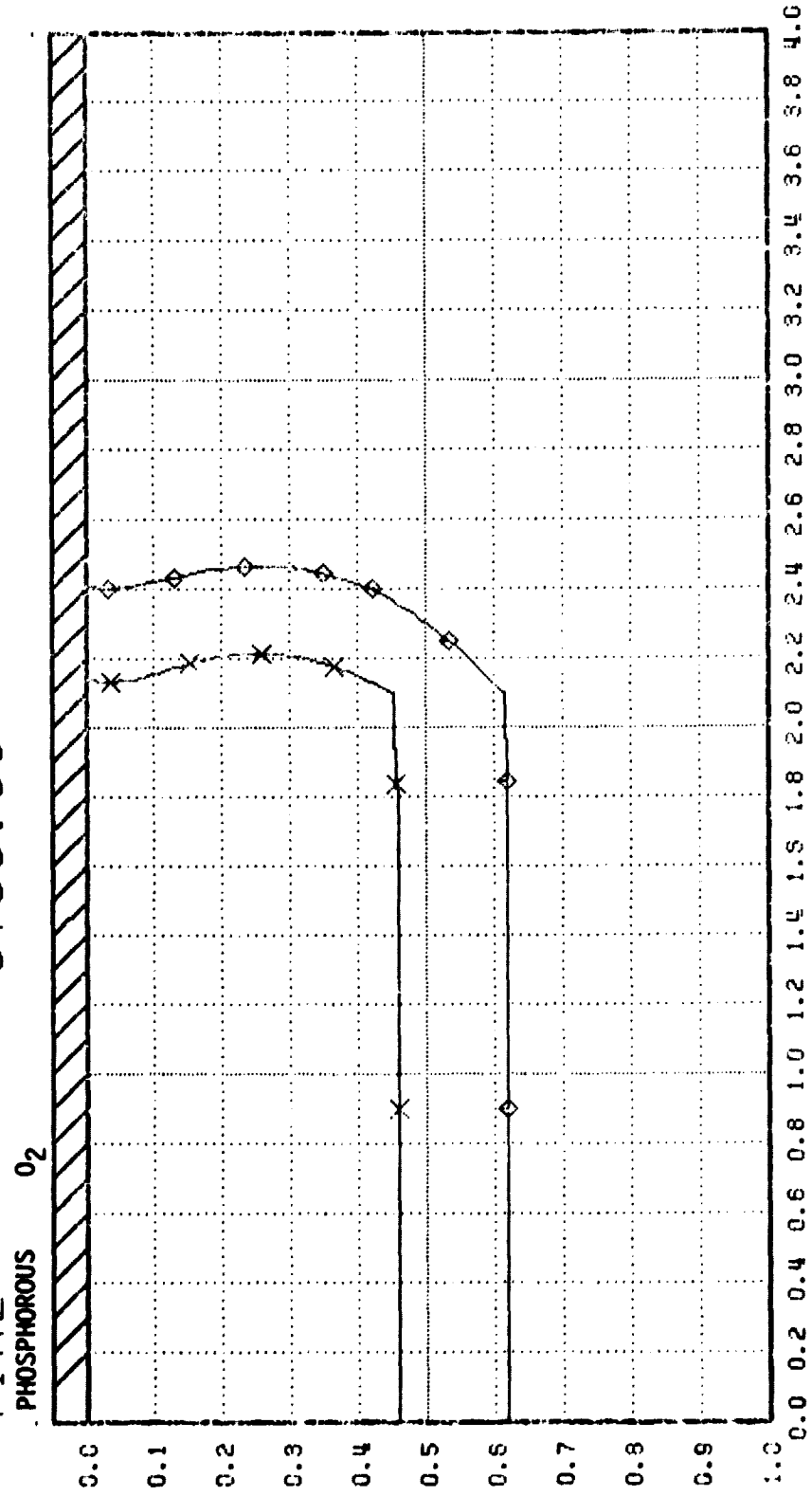
B 22

λ^2 = 1.0E20
 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 60
 = 4320.00

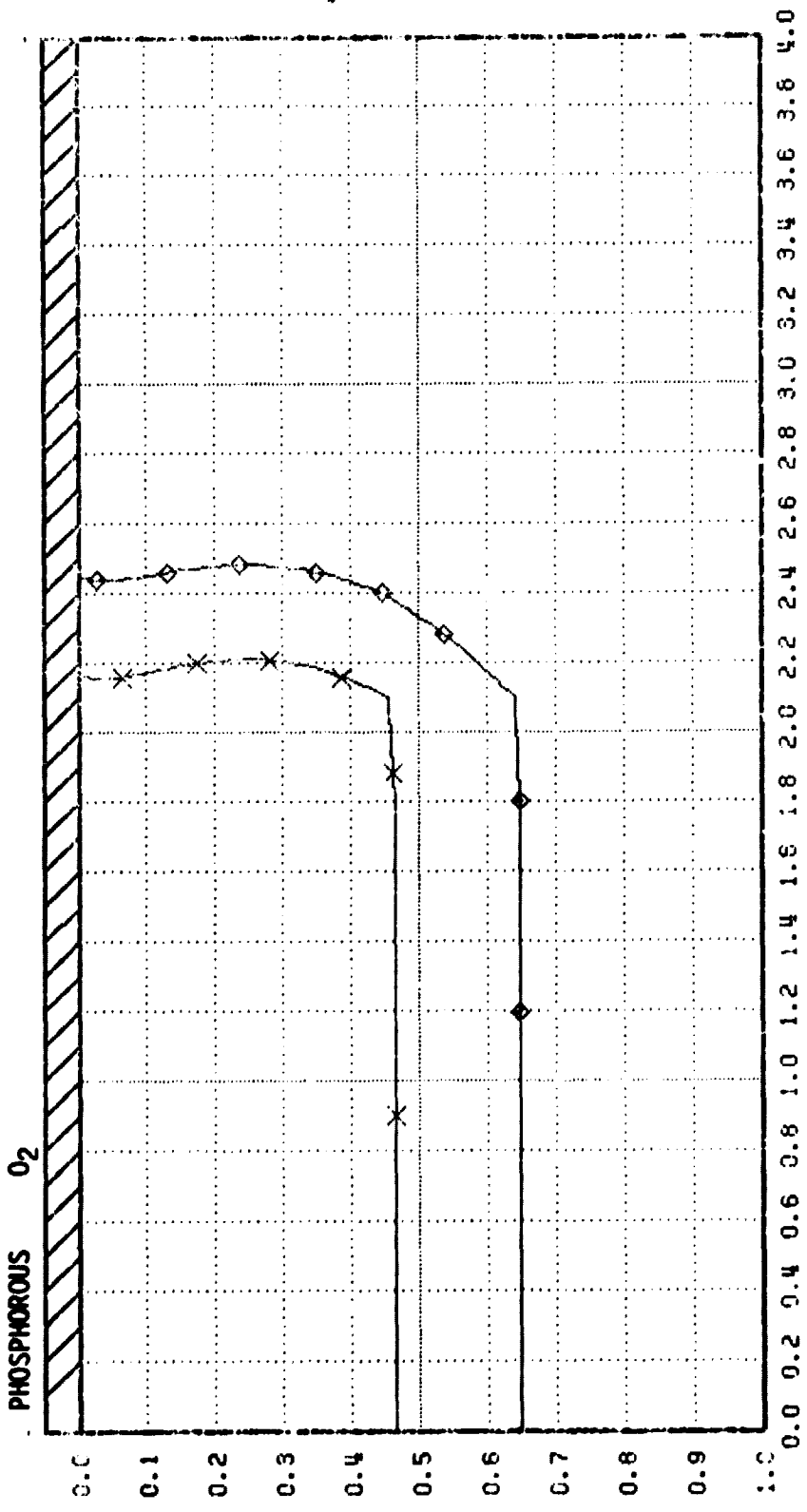


λ^2
 TEMPERATURE = 0.0000
 TIME STEP = 1000.
 TIME = 80
 TIME = 5760.00

E - 1.0E20
 O - 1.0E19
 A - 1.0E18
 + - 1.0E17
 X - 1.0E16
 ◇ - 1.0E15

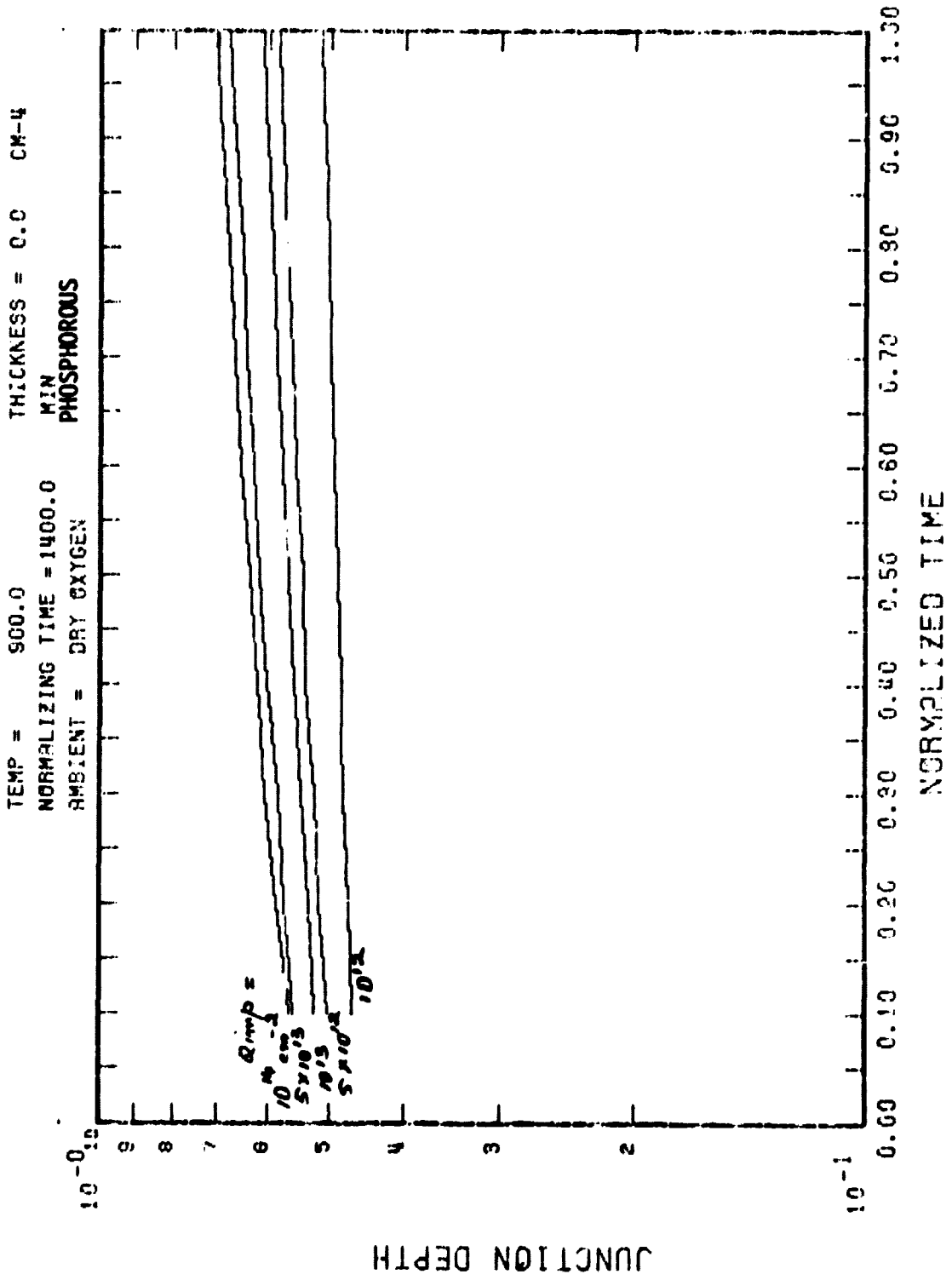


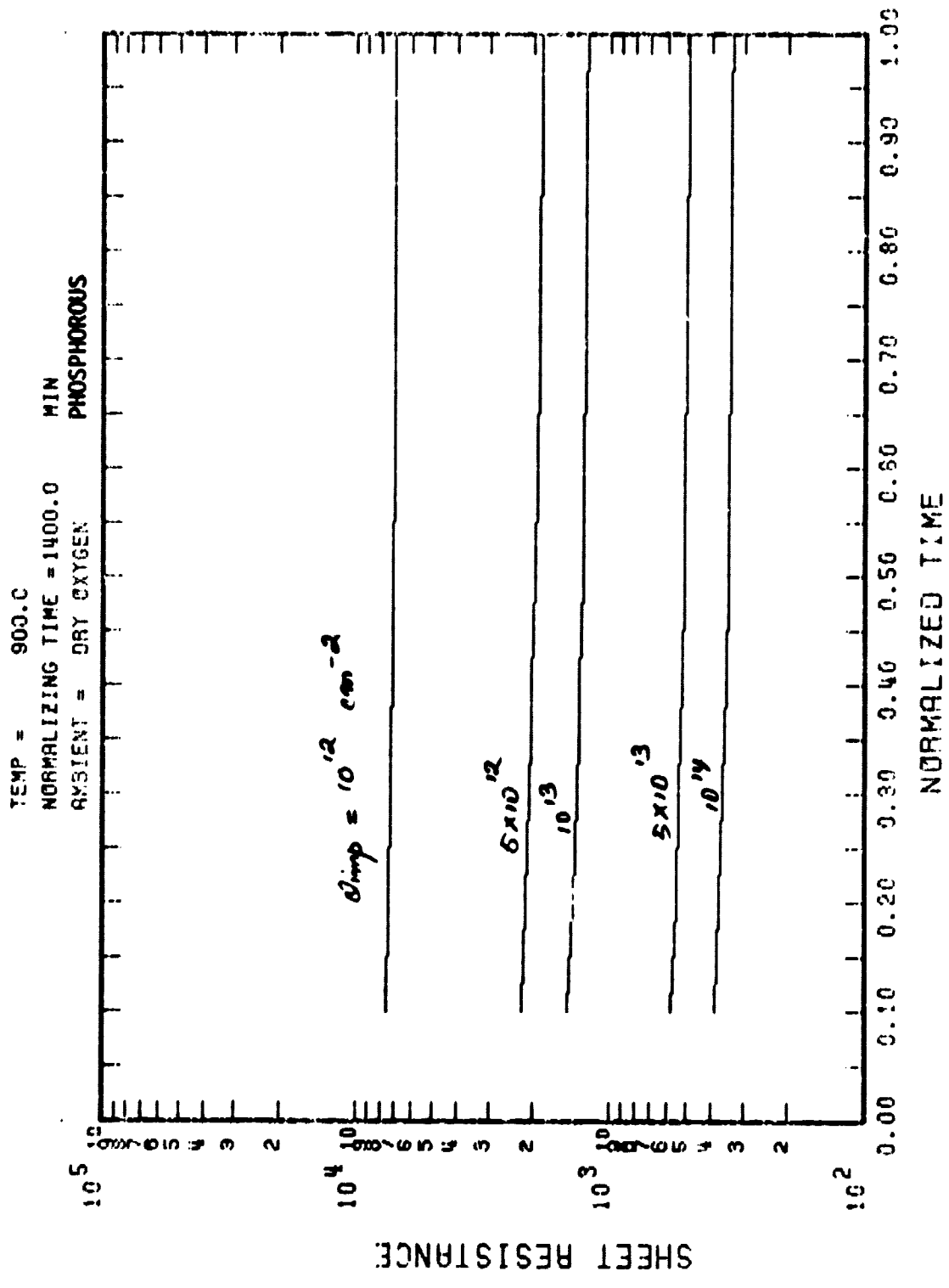
λ^2 = 1.0E20
 = 1.0E19
 = 1.0E18
 TEMPERATURE = 1000.
 TIME STEP = 100.
 TIME = 7200.00



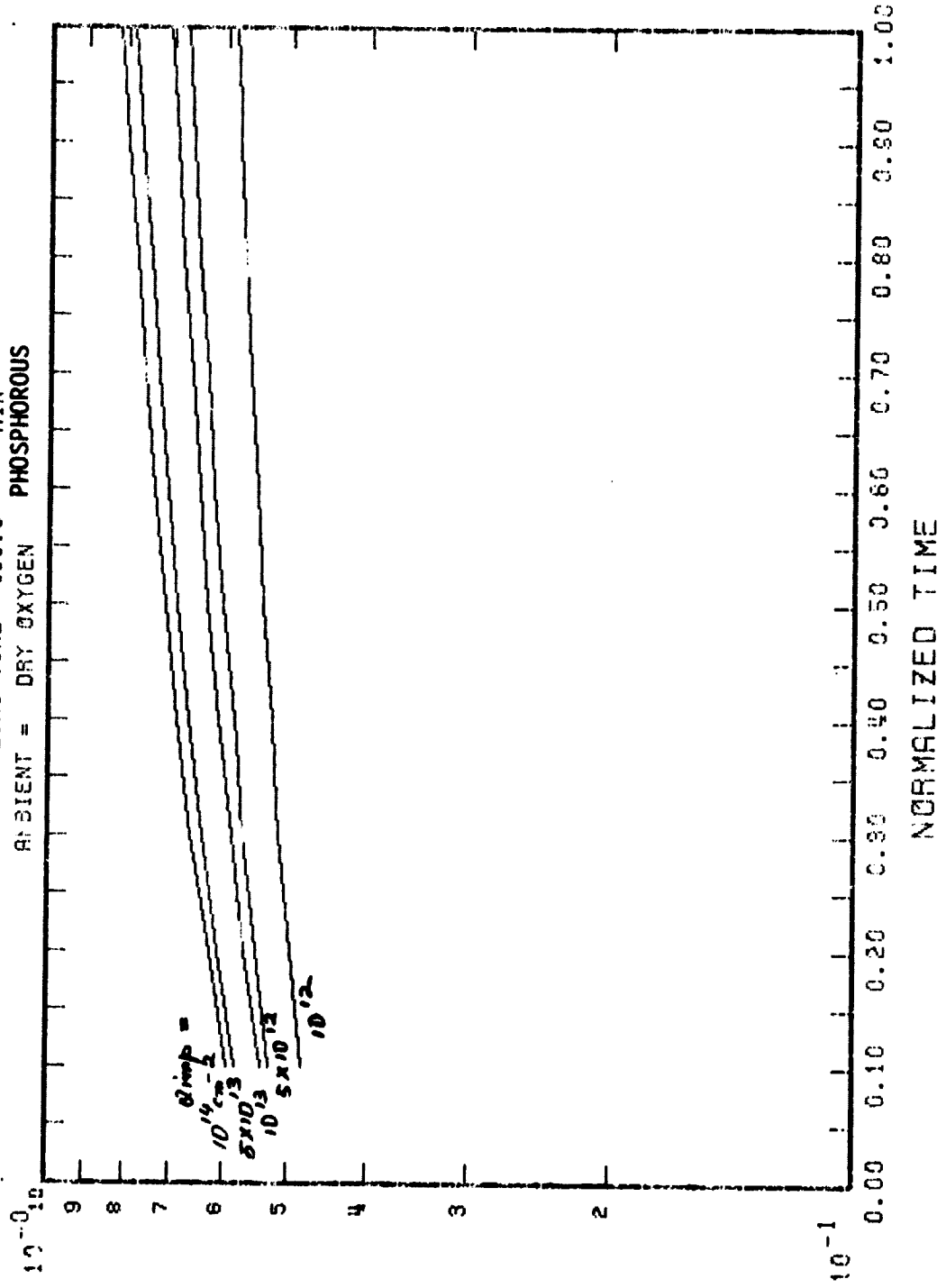
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TEMP = 950.0 THICKNESS = 0.0 CM-4
NORMALIZING TIME = 483.3 MIN
ATBIENT = DRY OXYGEN PHOSPHOROUS

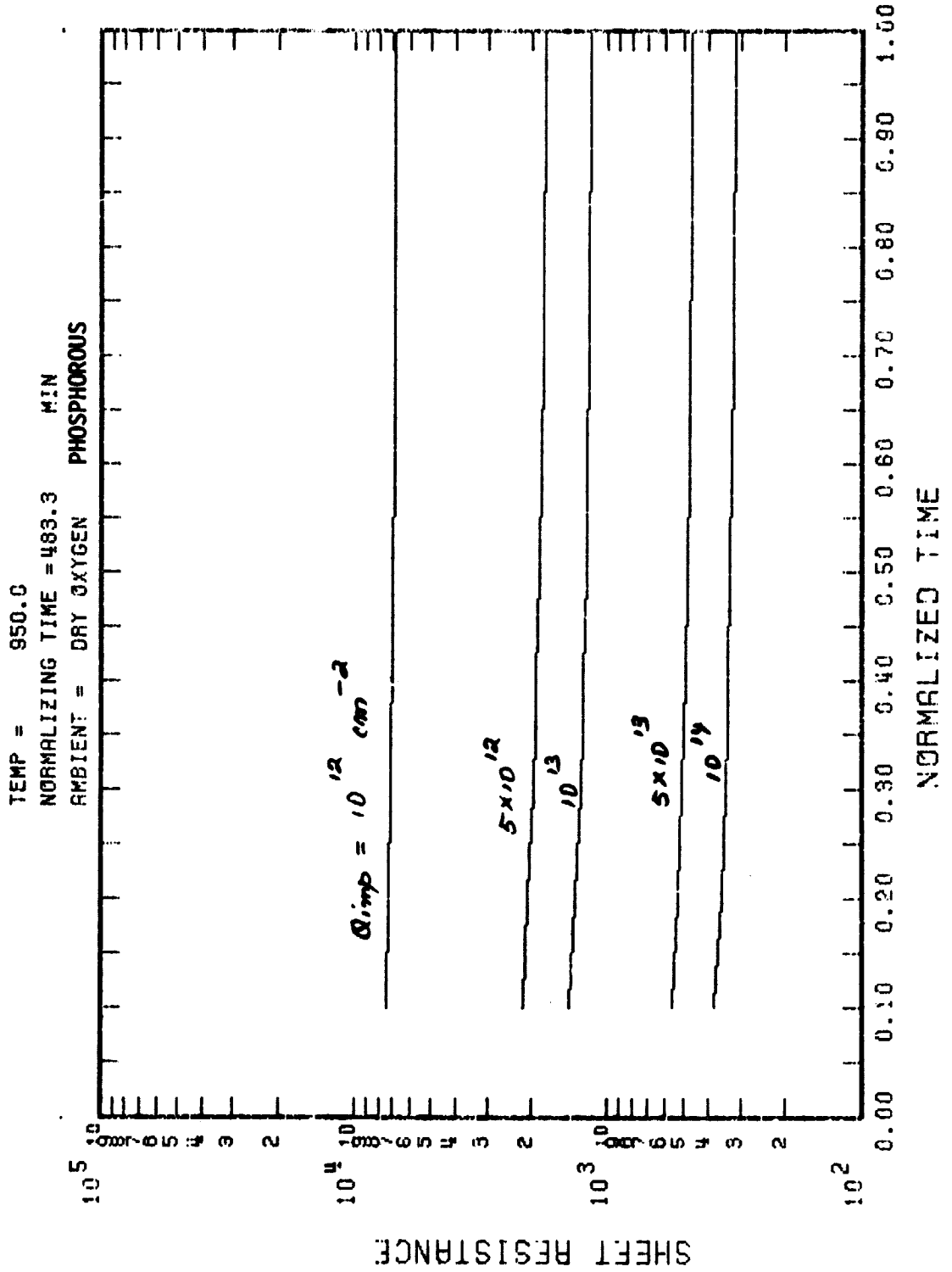


JUNCTION DEPTH

NORMALIZED TIME

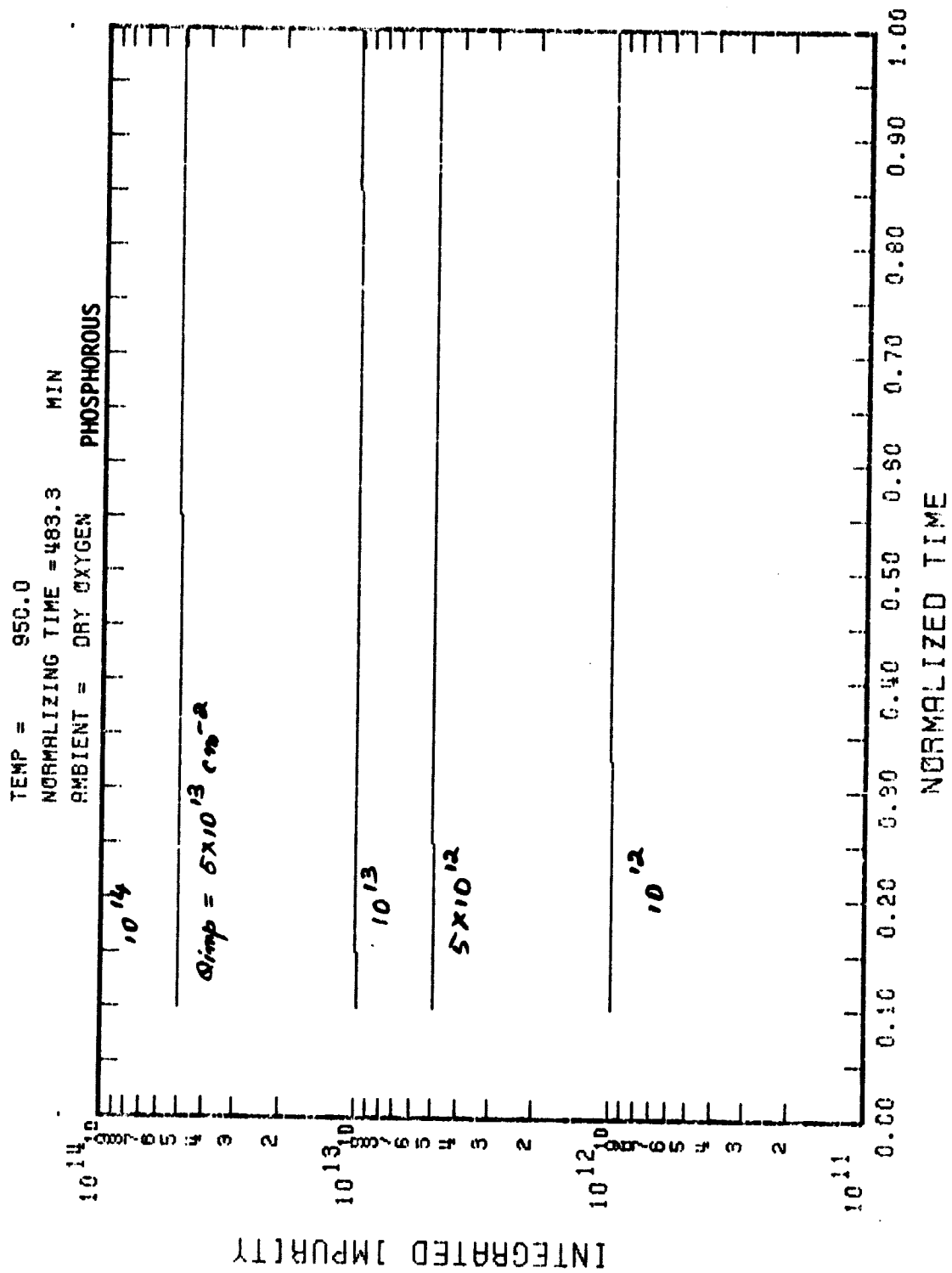
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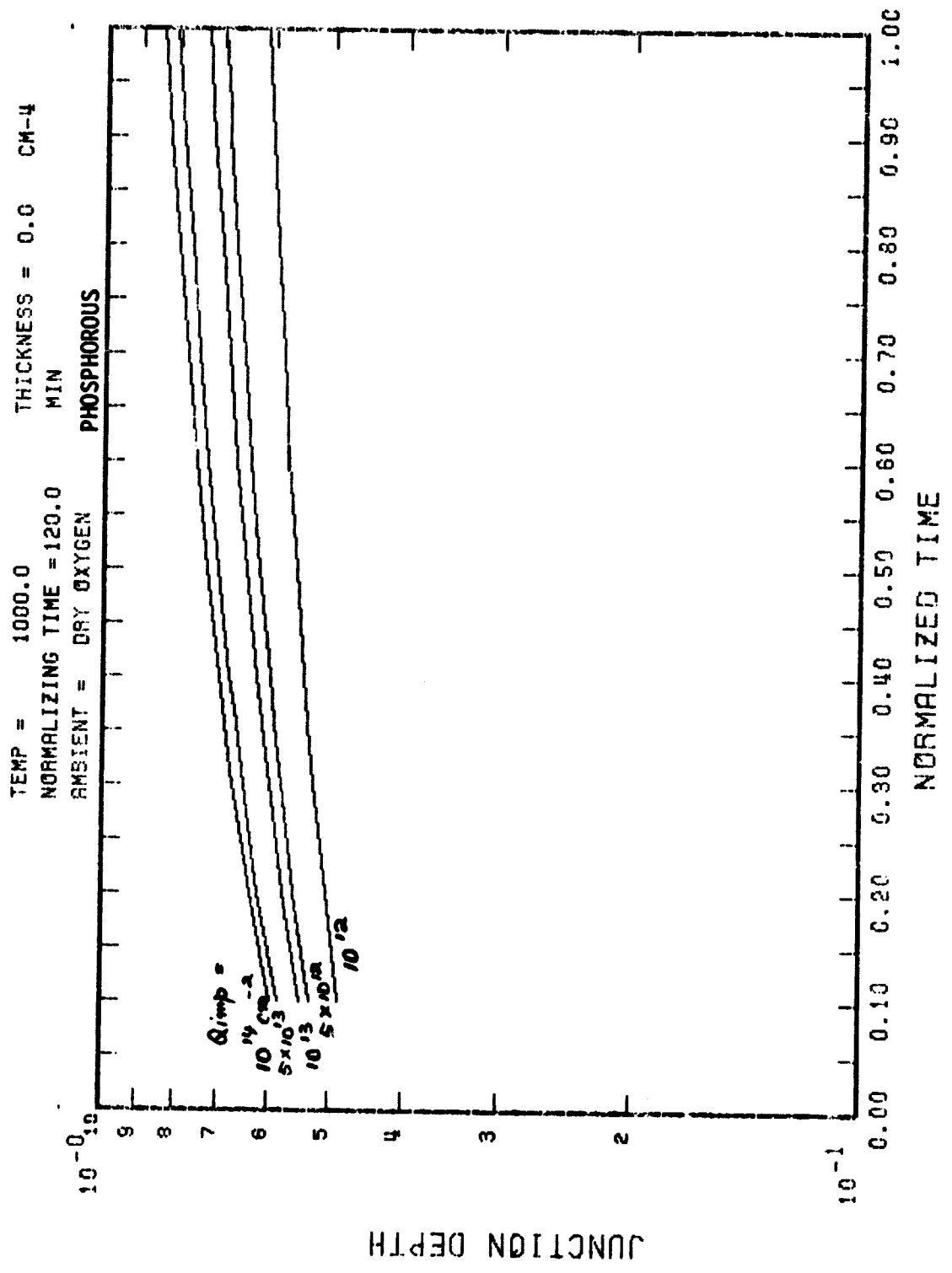
B 29



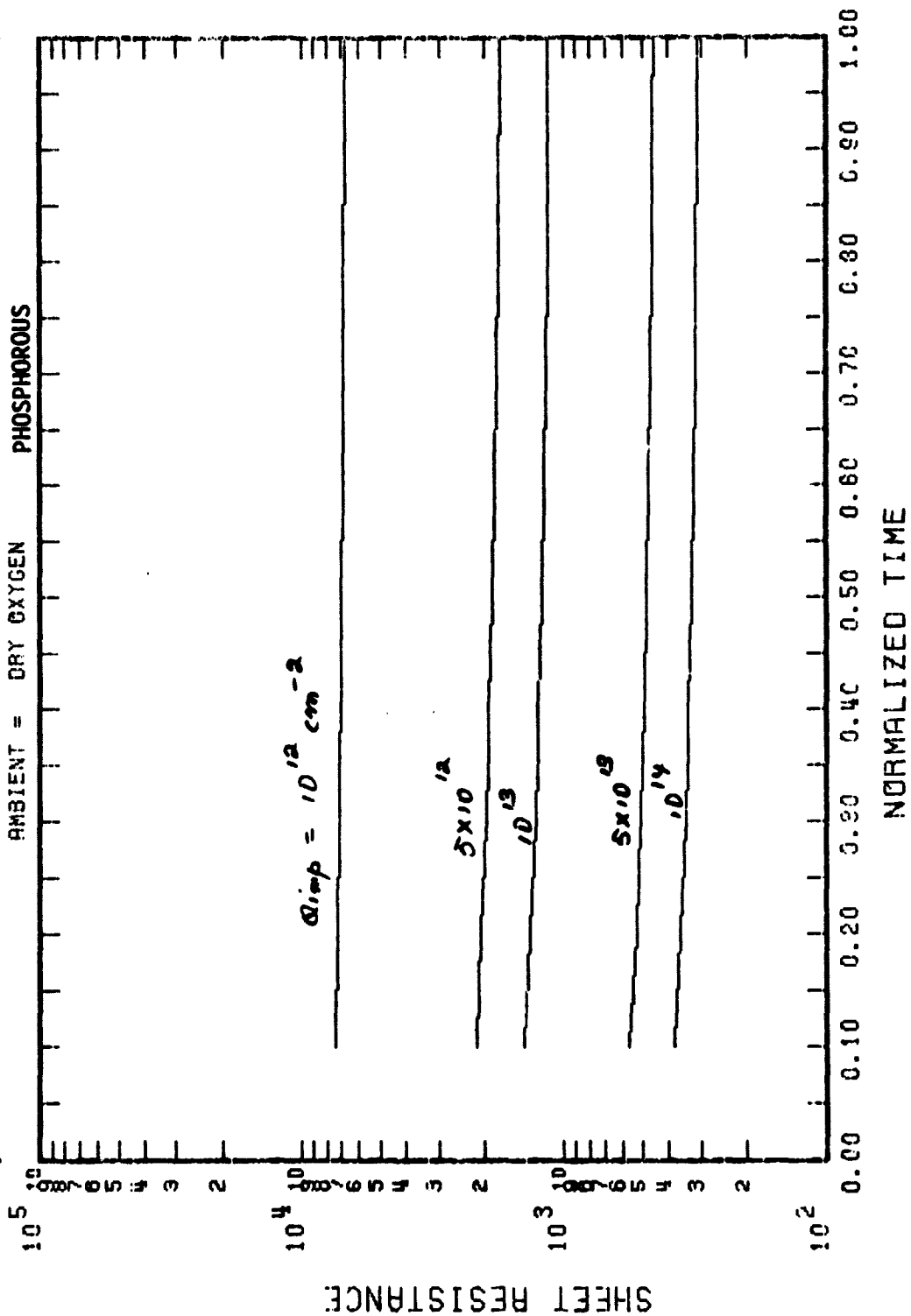
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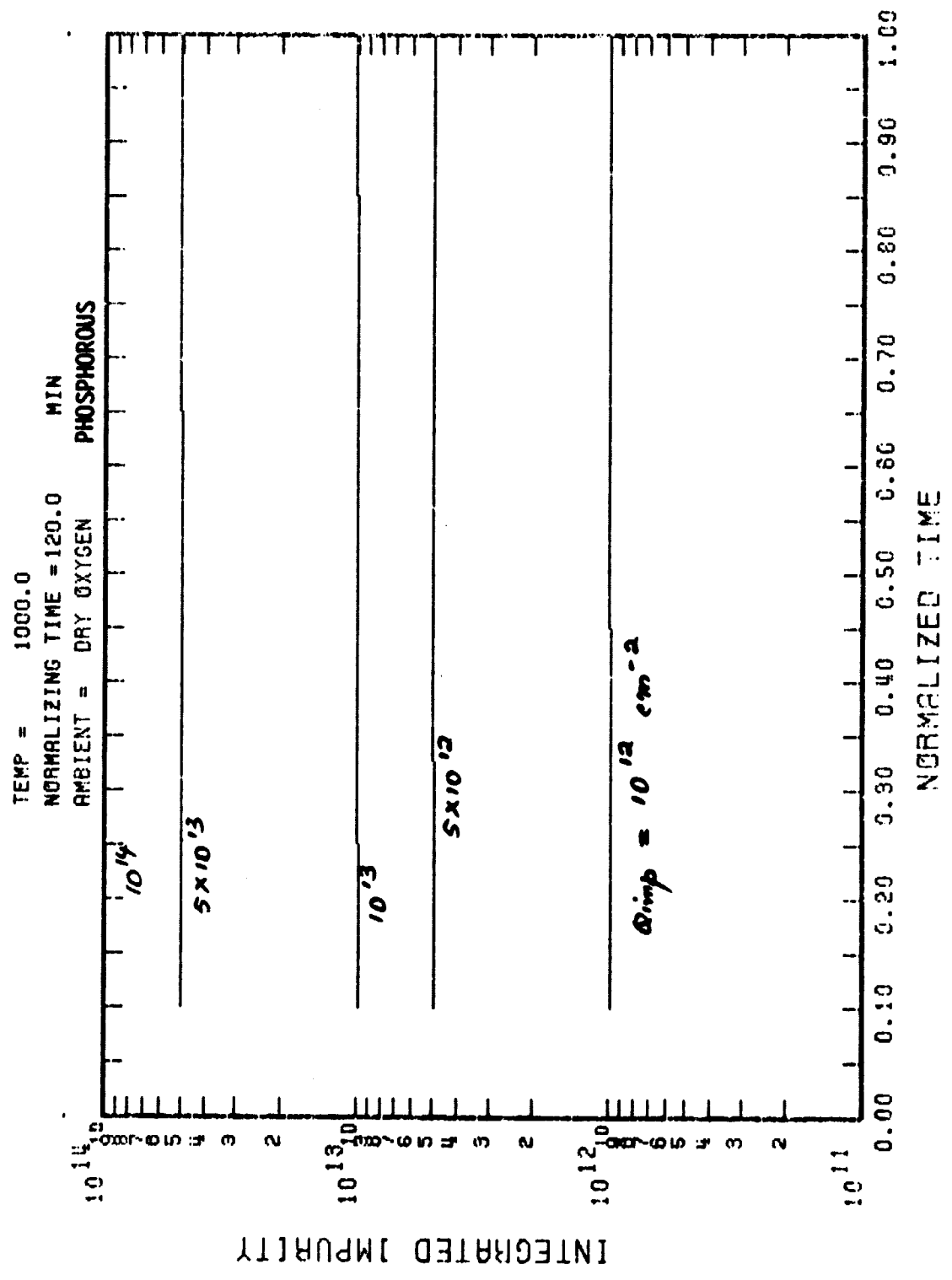


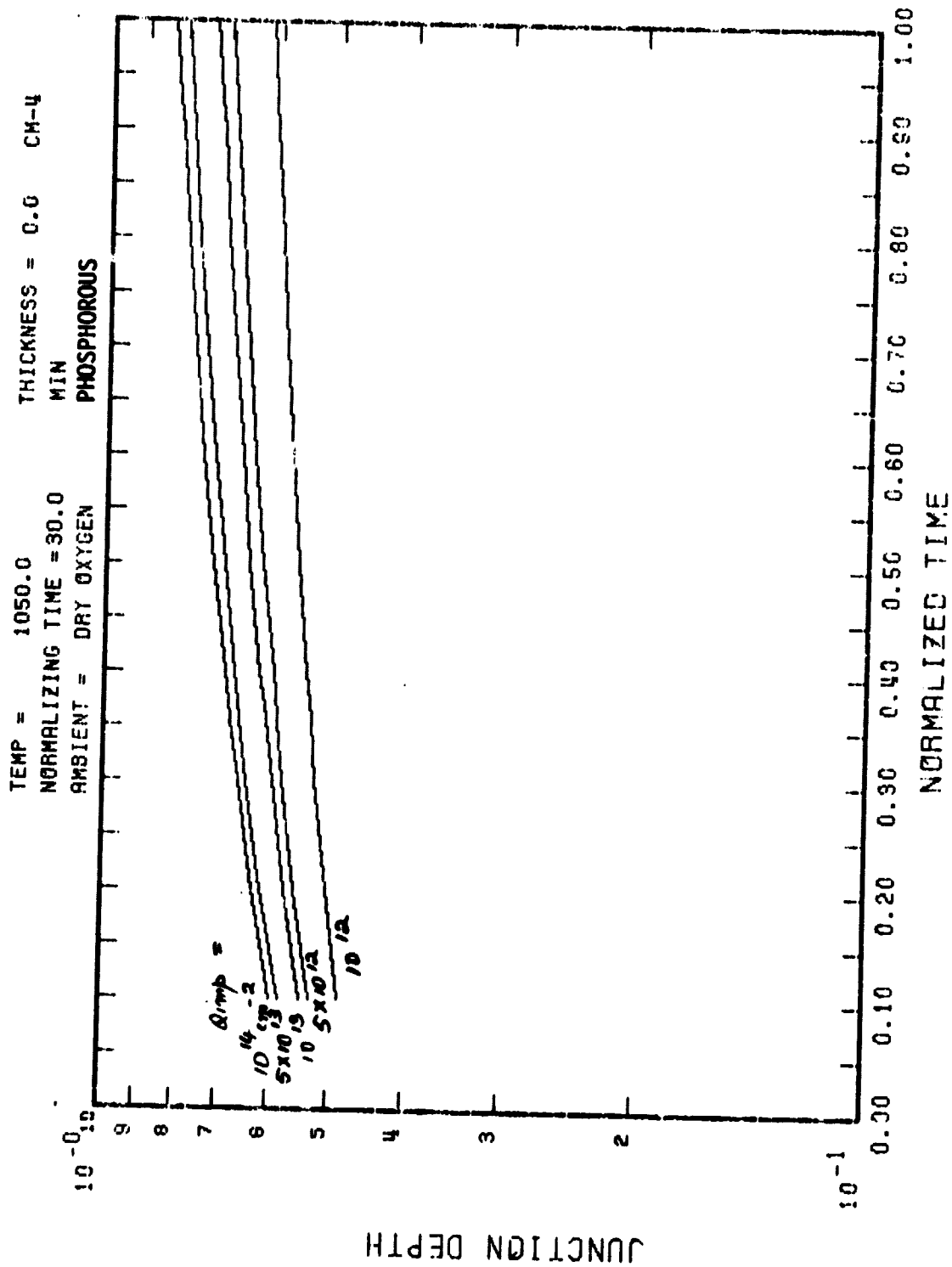


TEMP = 1000.0
NORMALIZING TIME = 120.0 MIN
AMBIENT = DRY OXYGEN PHOSPHOROUS



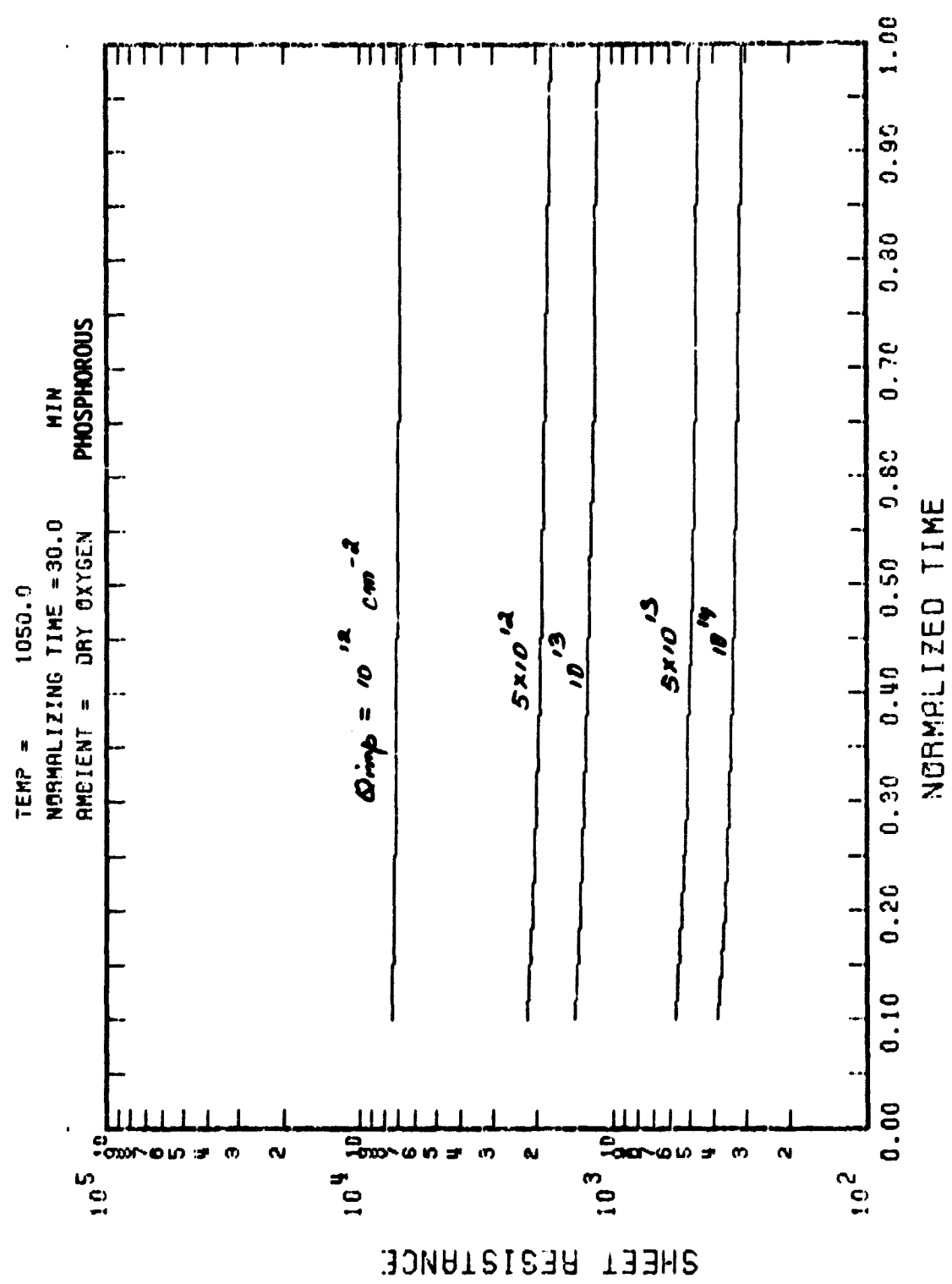
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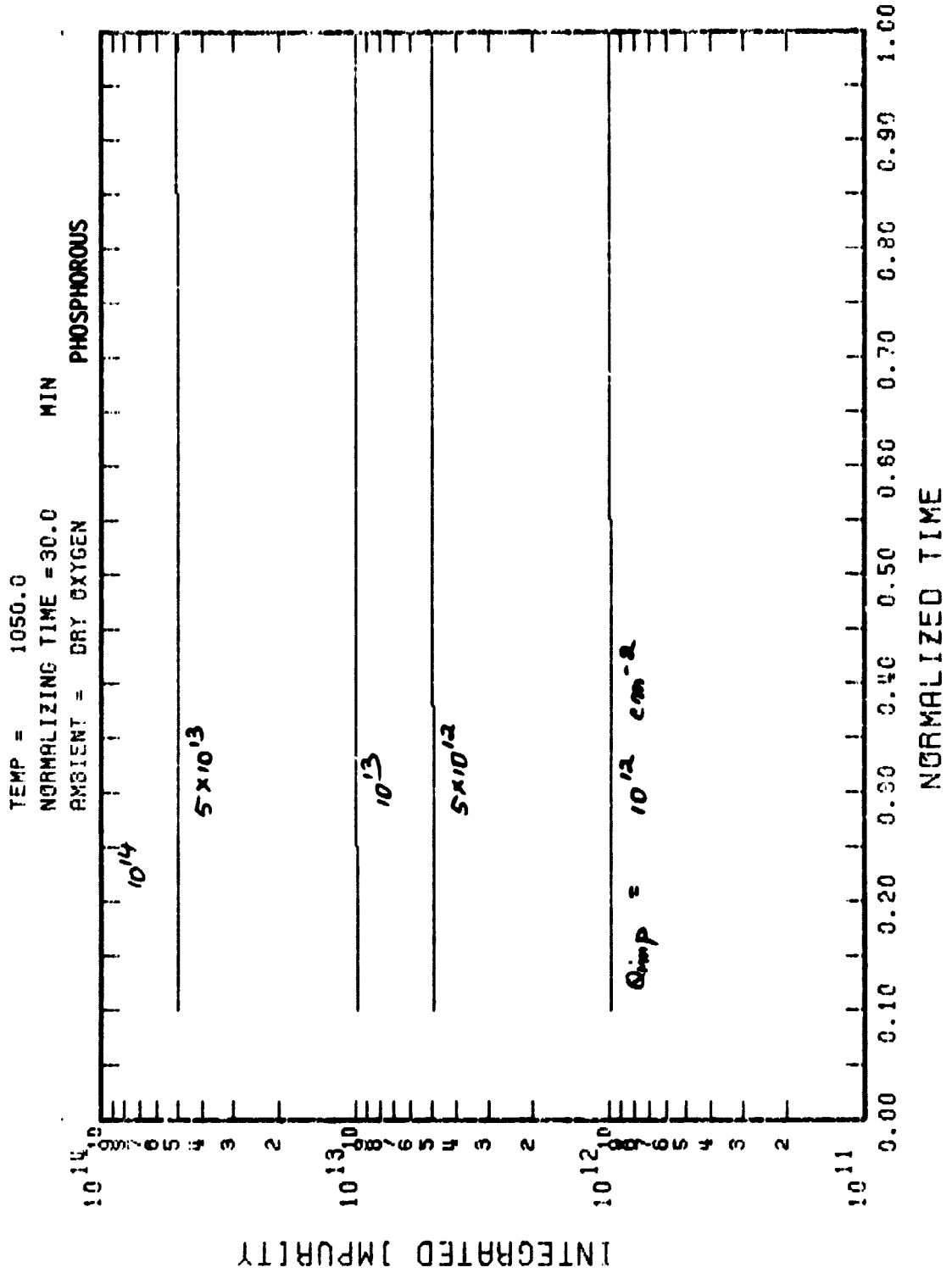


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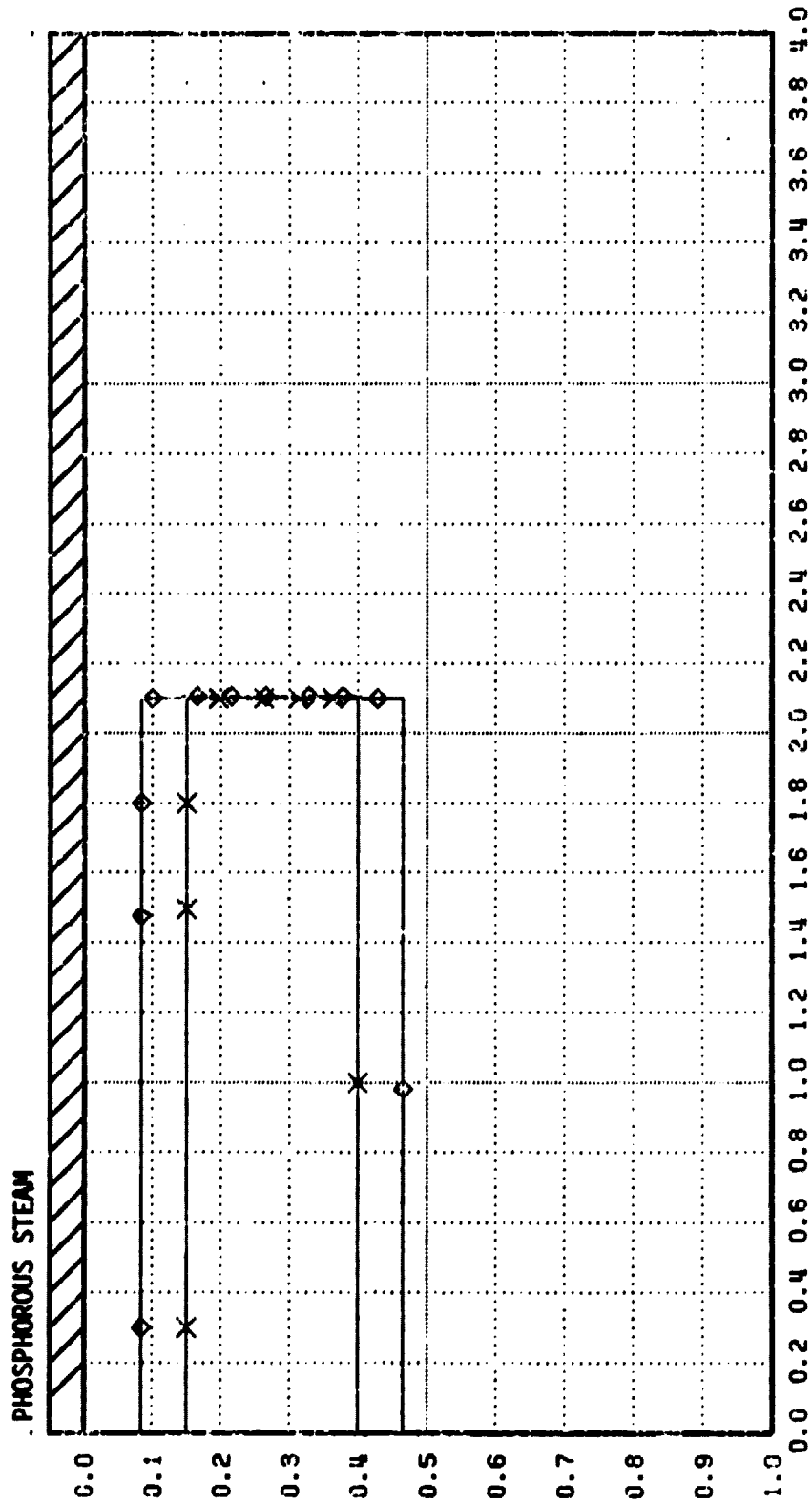


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INTEGRATED IMPURITY

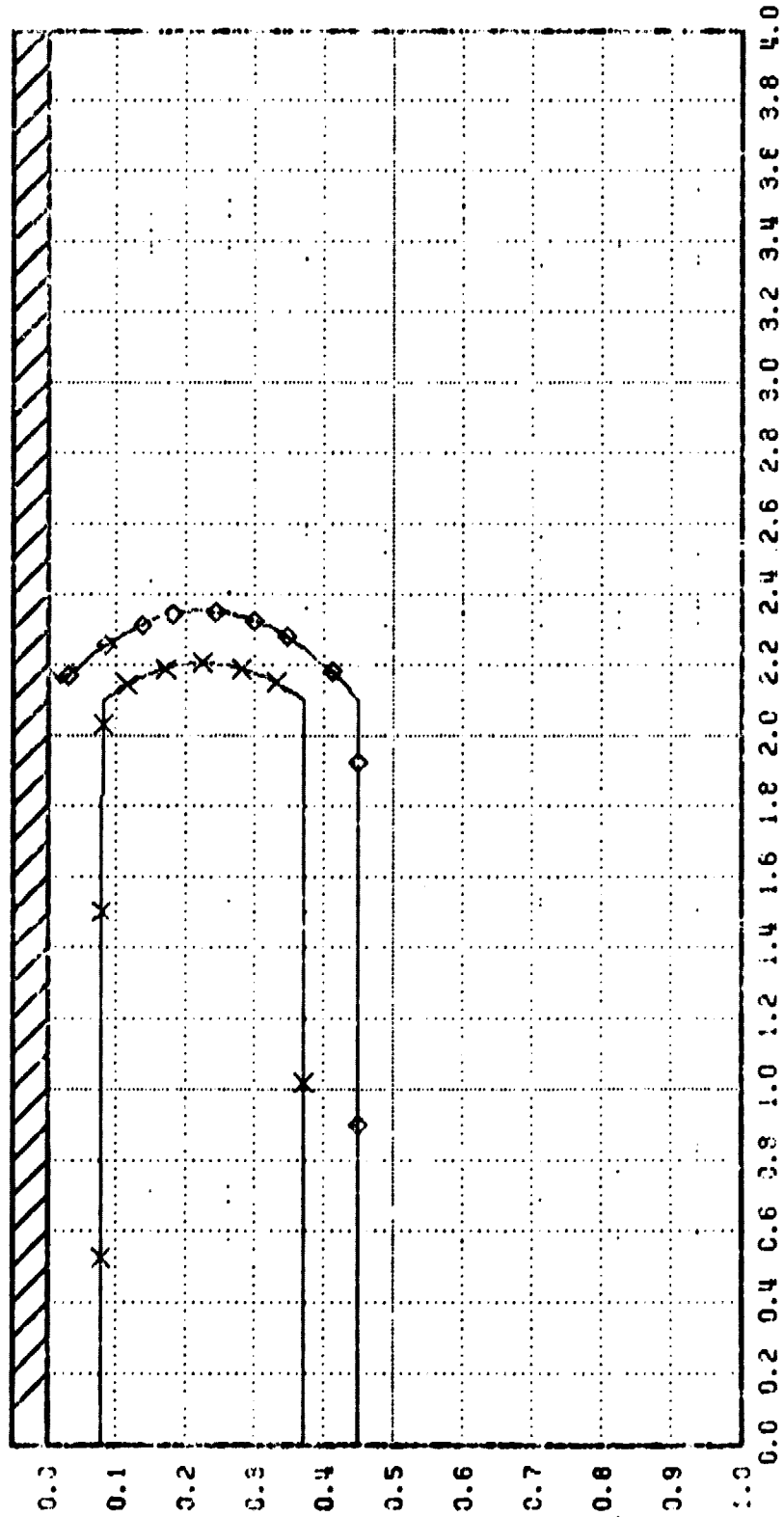
λ^2 = 0.0000
 TEMPERATURE = 1000.
 TIME STEP = 0
 TIME = 0.00
 E - 1.0E20
 O - 1.0E19
 A - 1.0E18
 + - 1.0E17
 X - 1.0E16
 D - 1.0E15



λ^2 = 0.0000
 TEMPERATURE = 1000.
 TIME STEP = 20
 TIME = 720.00

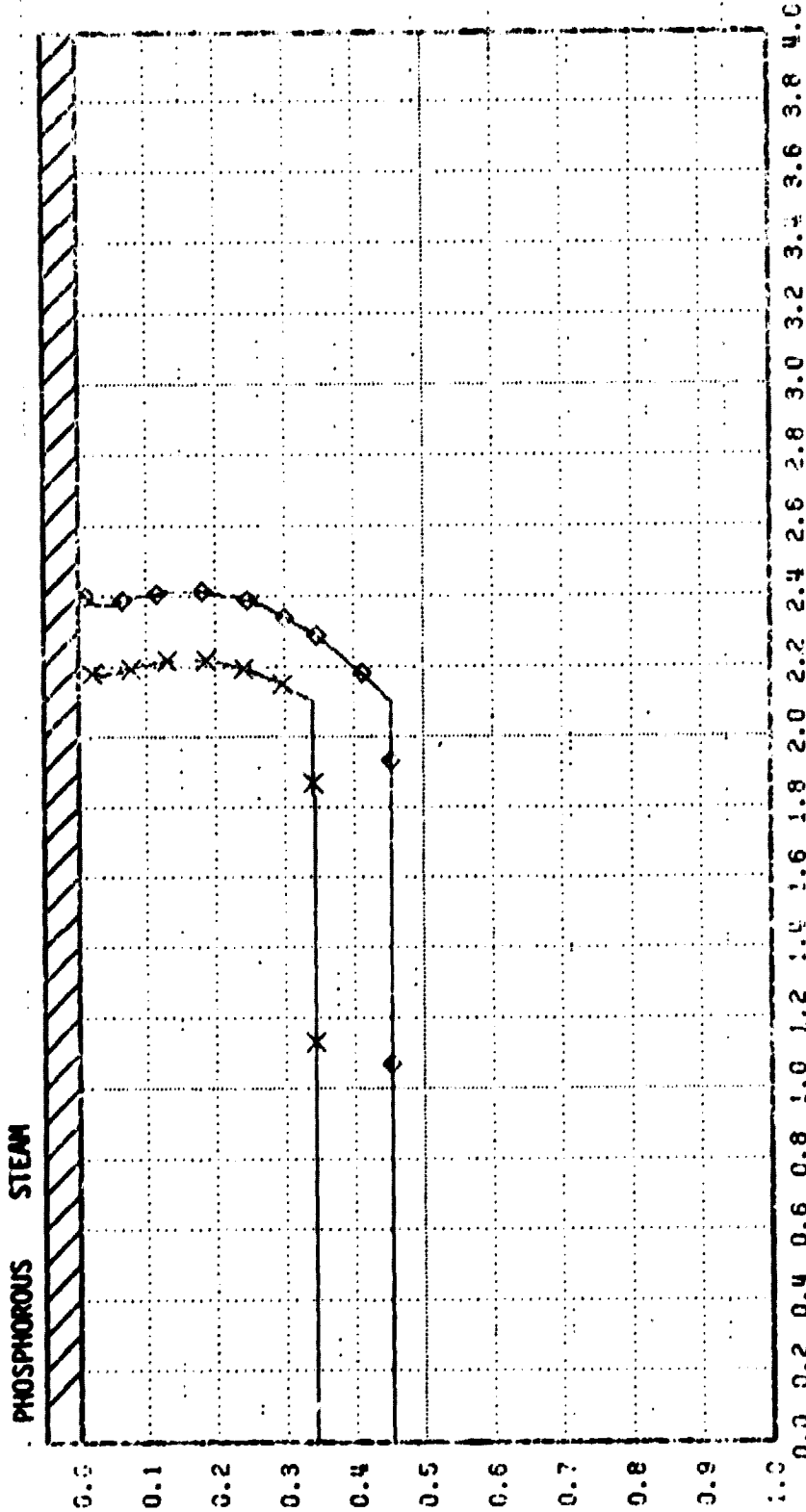
E - 1.0E20
 O - 1.0E19
 A - 1.0E18
 + - 1.0E17
 X - 1.0E16
 D - 1.0E15

PHOSPHOROUS STEAM



λ^2 = 0.0000
 TEMPERATURE = 1000.
 TIME STEP = 60
 TIME = 2160.00

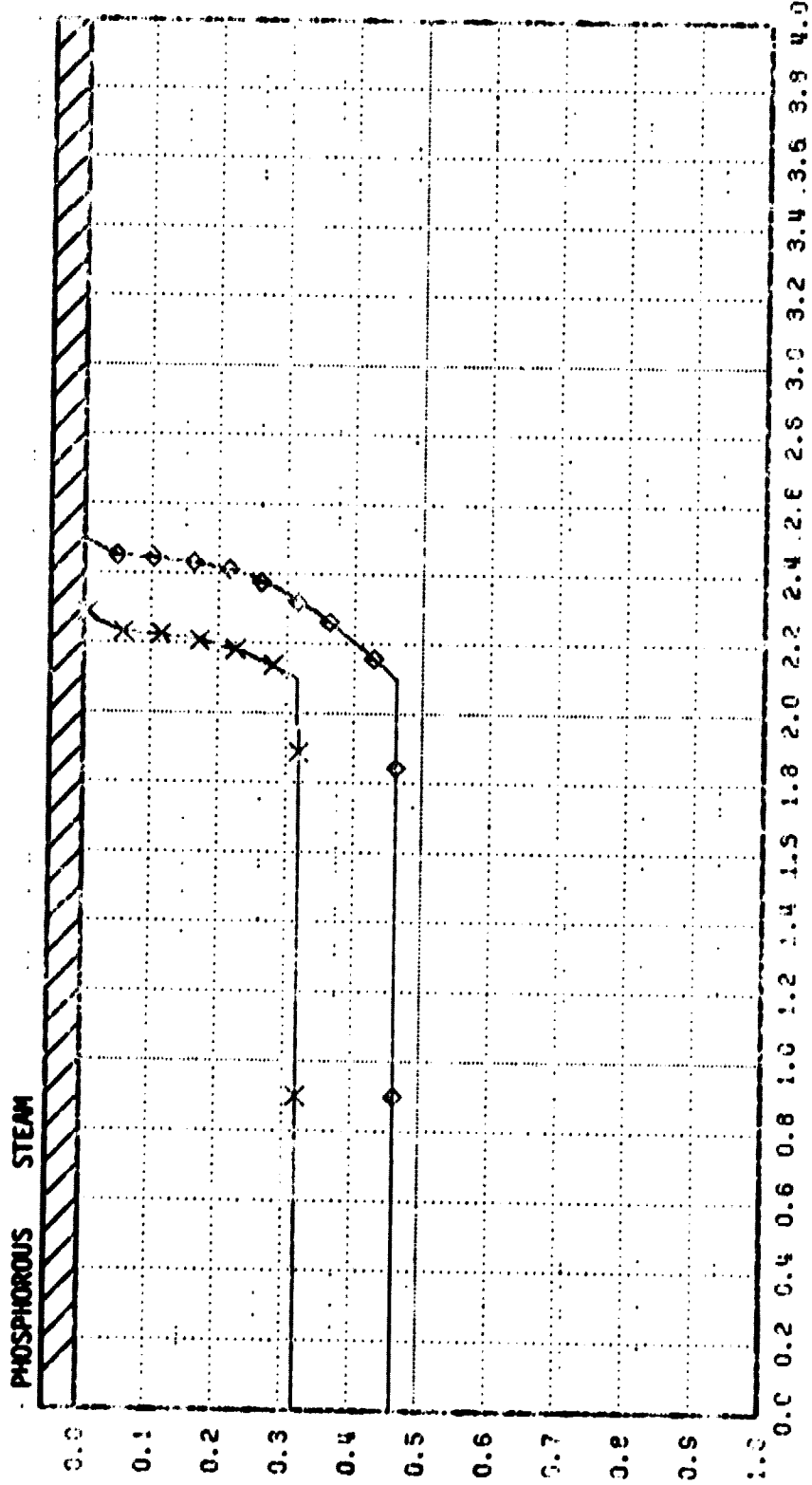
E - 1.0E20
 O - 1.0E18
 A - 1.0E18
 + - 1.0E17
 X - 1.0E18
 D - 1.0E15



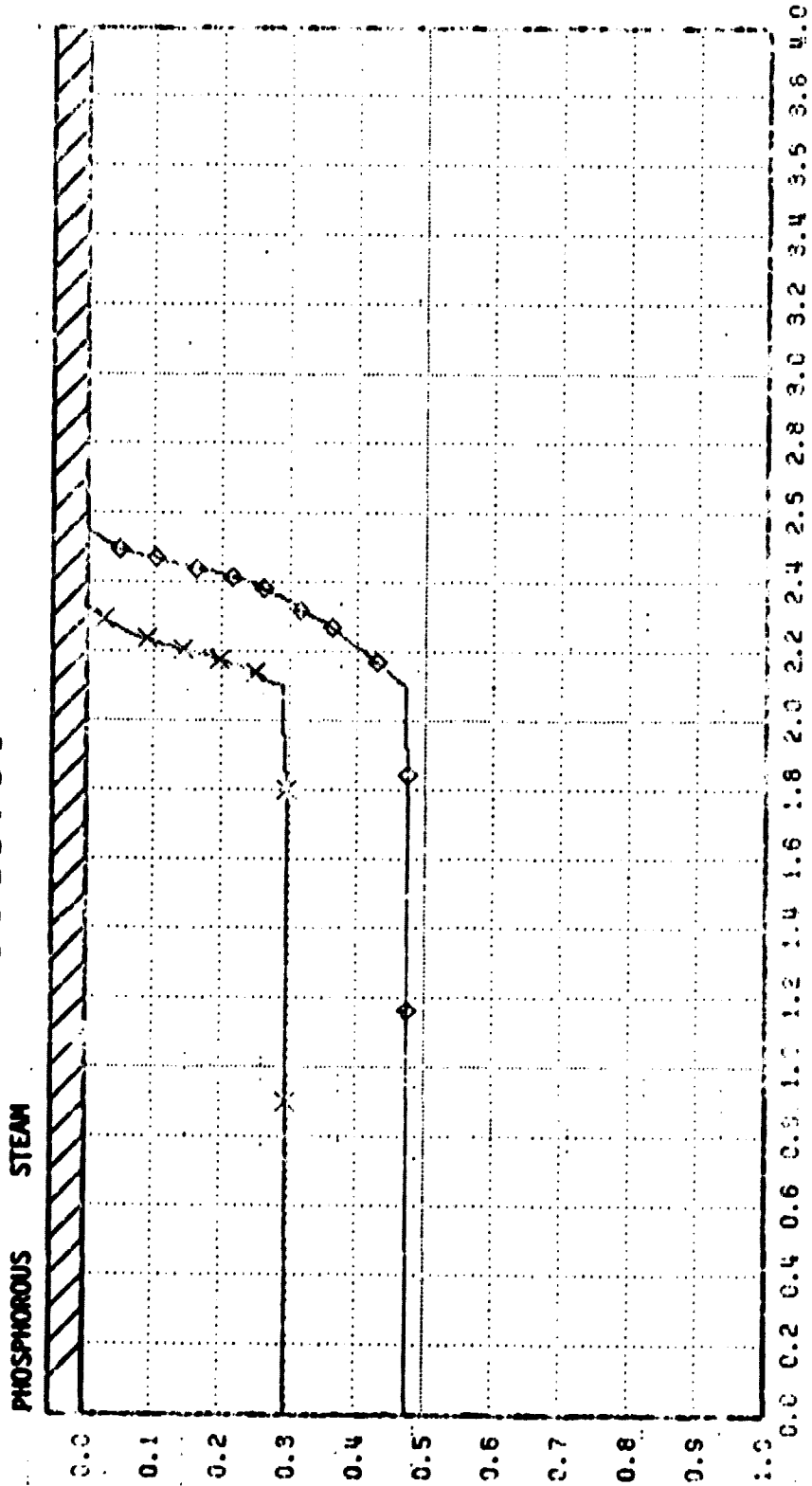
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$\lambda^2 = 0.0000$
 TEMPERATURE = 1000.
 TIME STEP = 100
 TIME = 3500.00

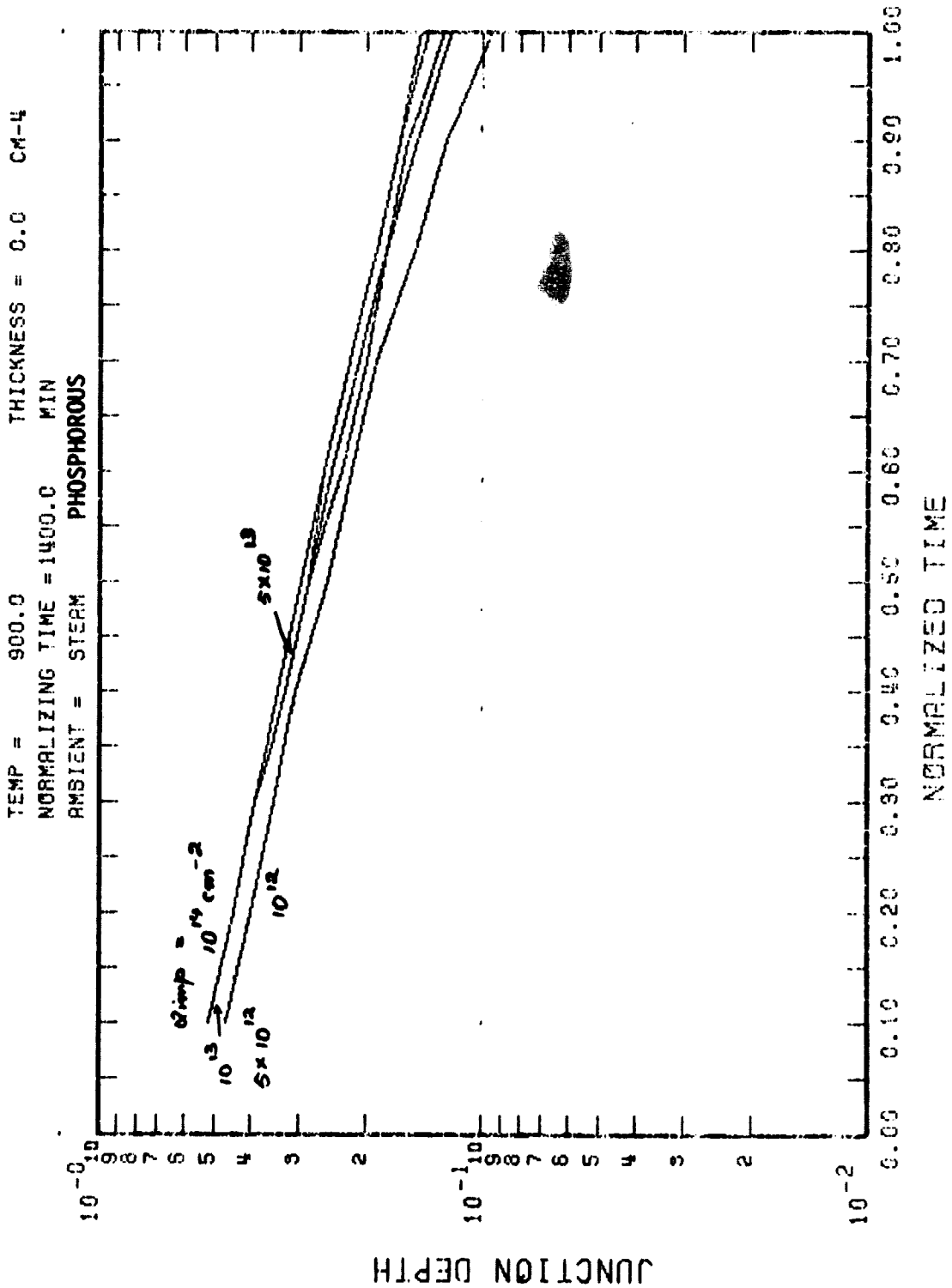
□ - 1.0E20
 ○ - 1.0E19
 △ - 1.0E18
 + - 1.0E17
 x - 1.0E16
 ◇ - 1.0E15



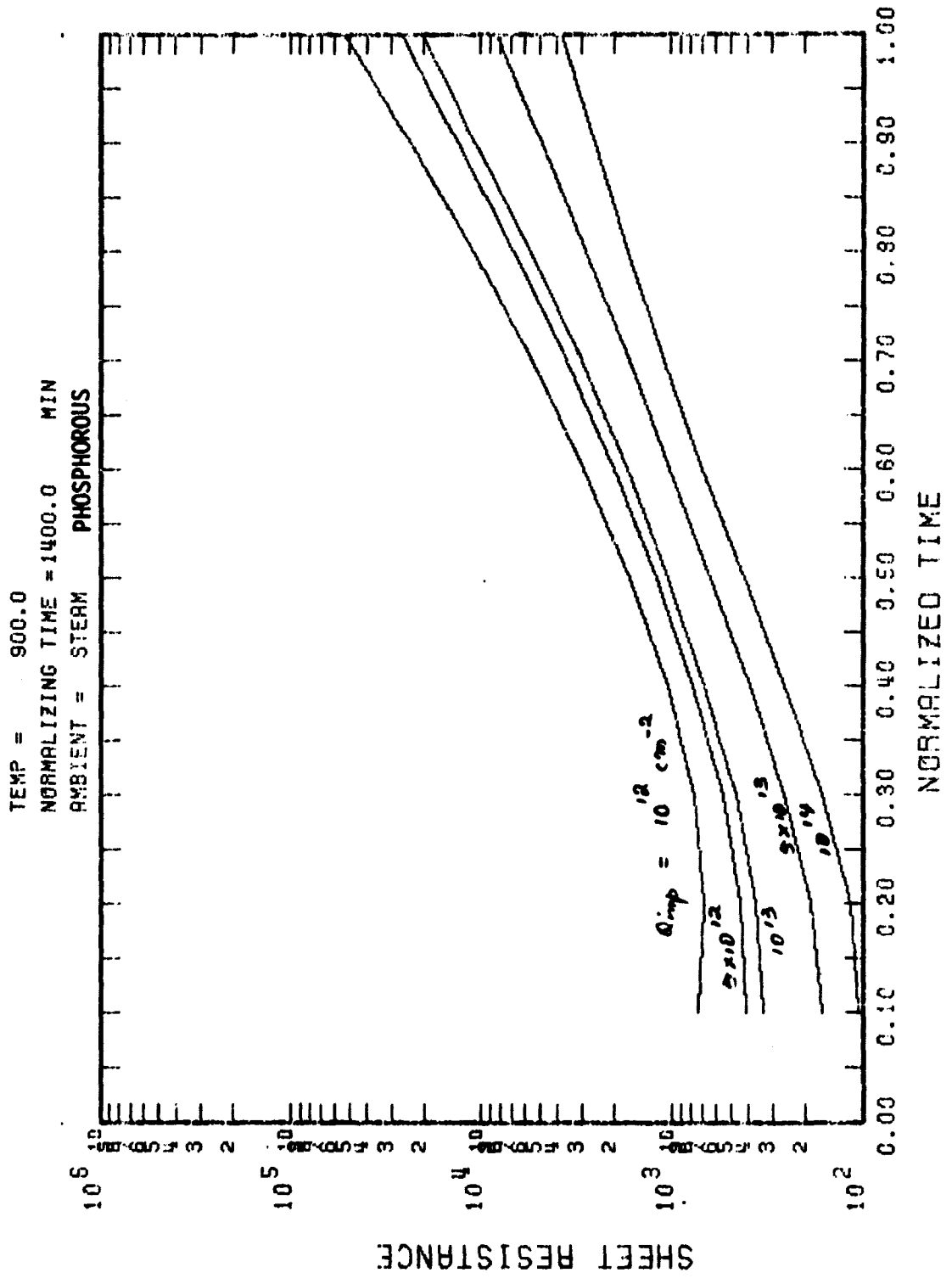
λ^2 = 1.0529
 E = 1.0515
 = 0.0000
 TEMPERATURE = 1000.
 TIME STEP = 140
 TIME = 5040.00



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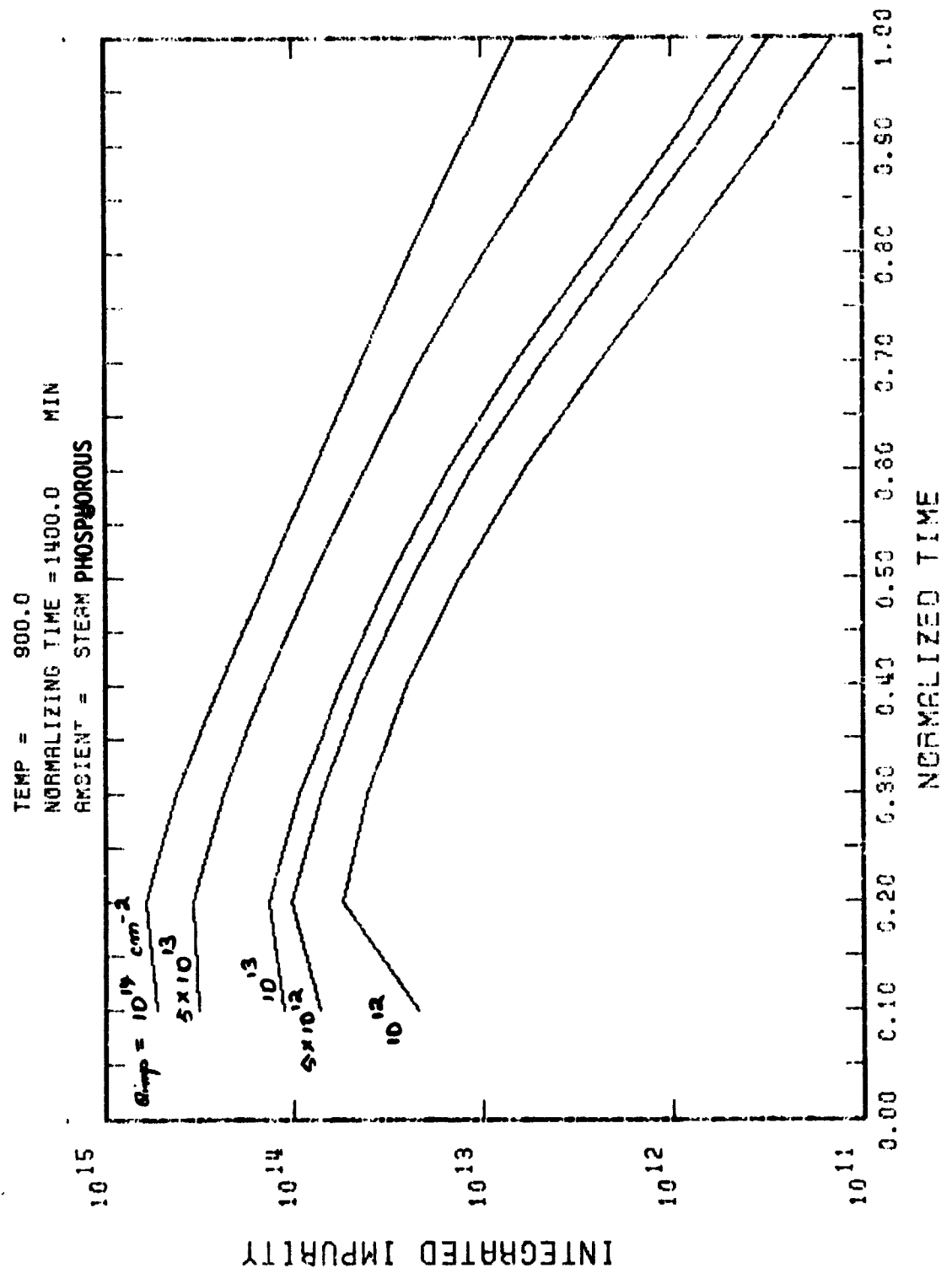
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PHYSICS
LABORATORY

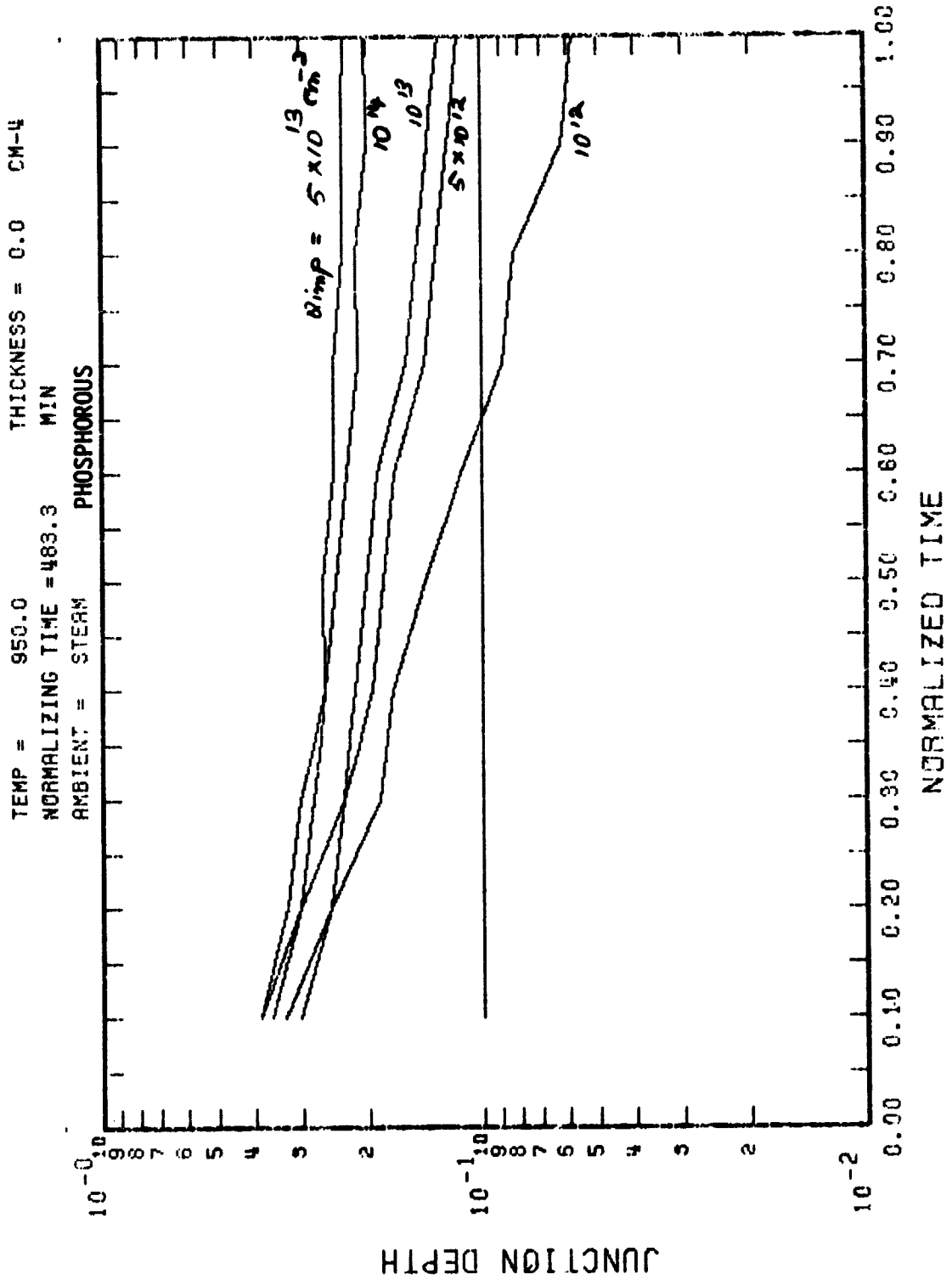
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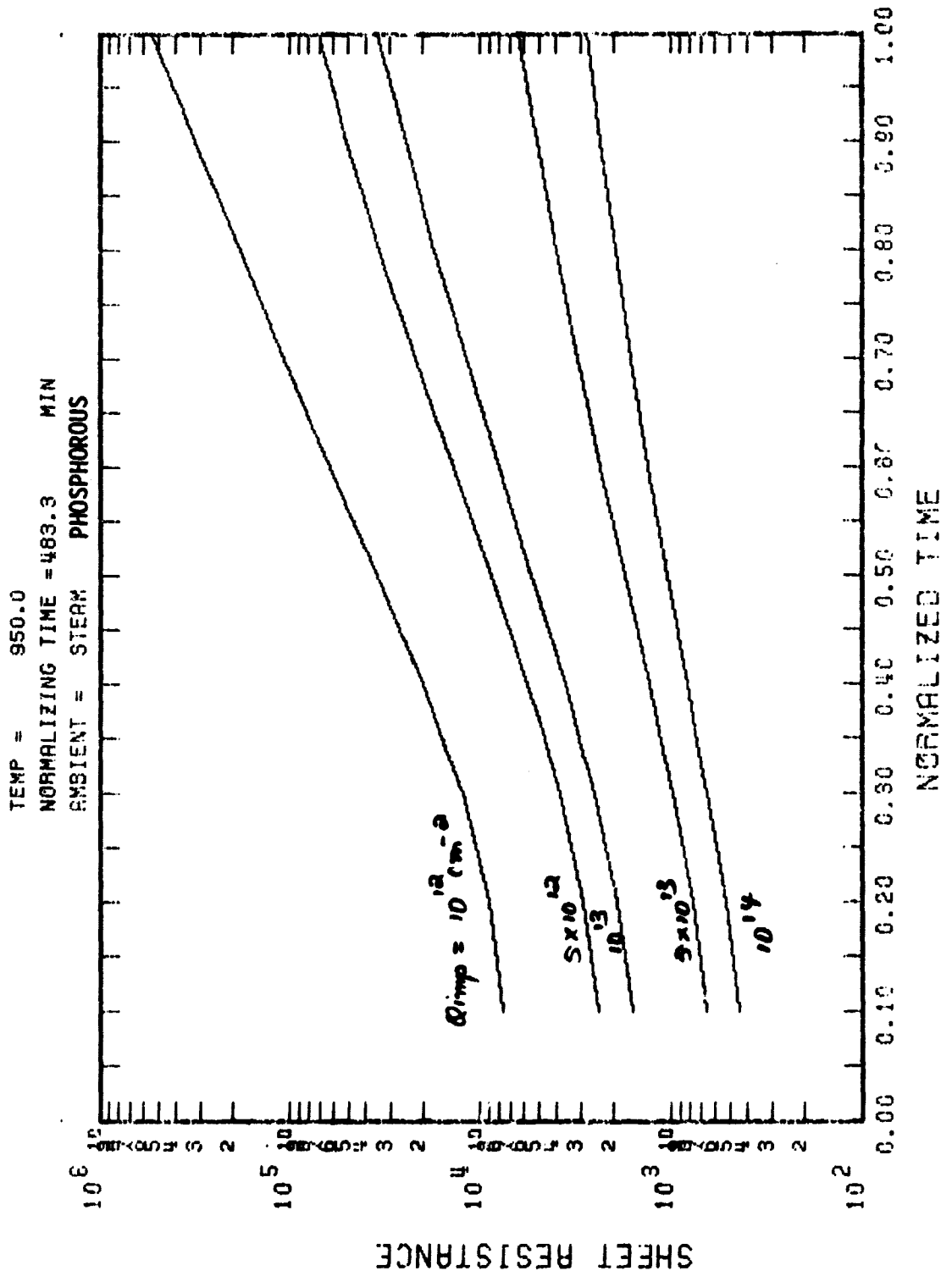


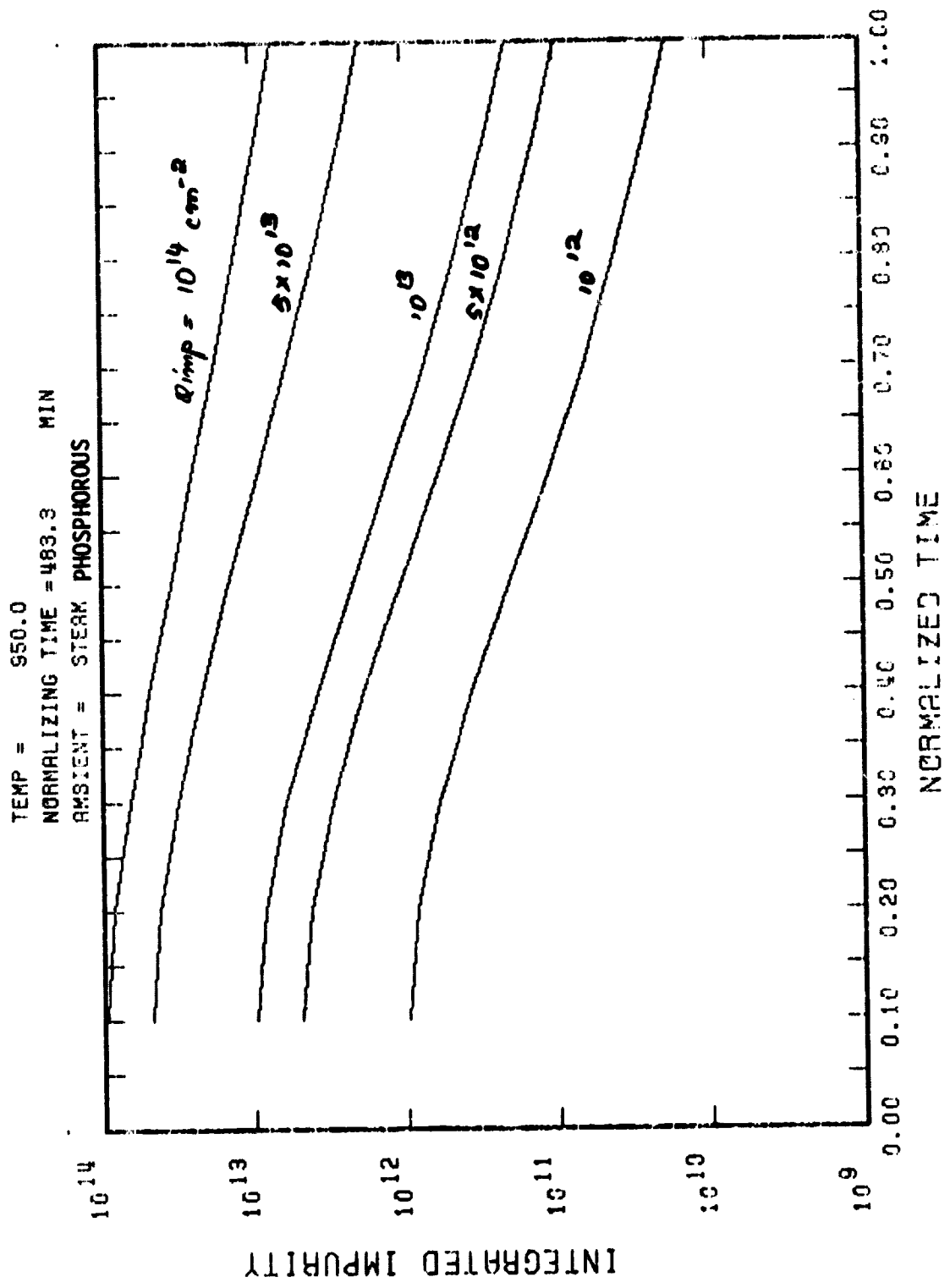
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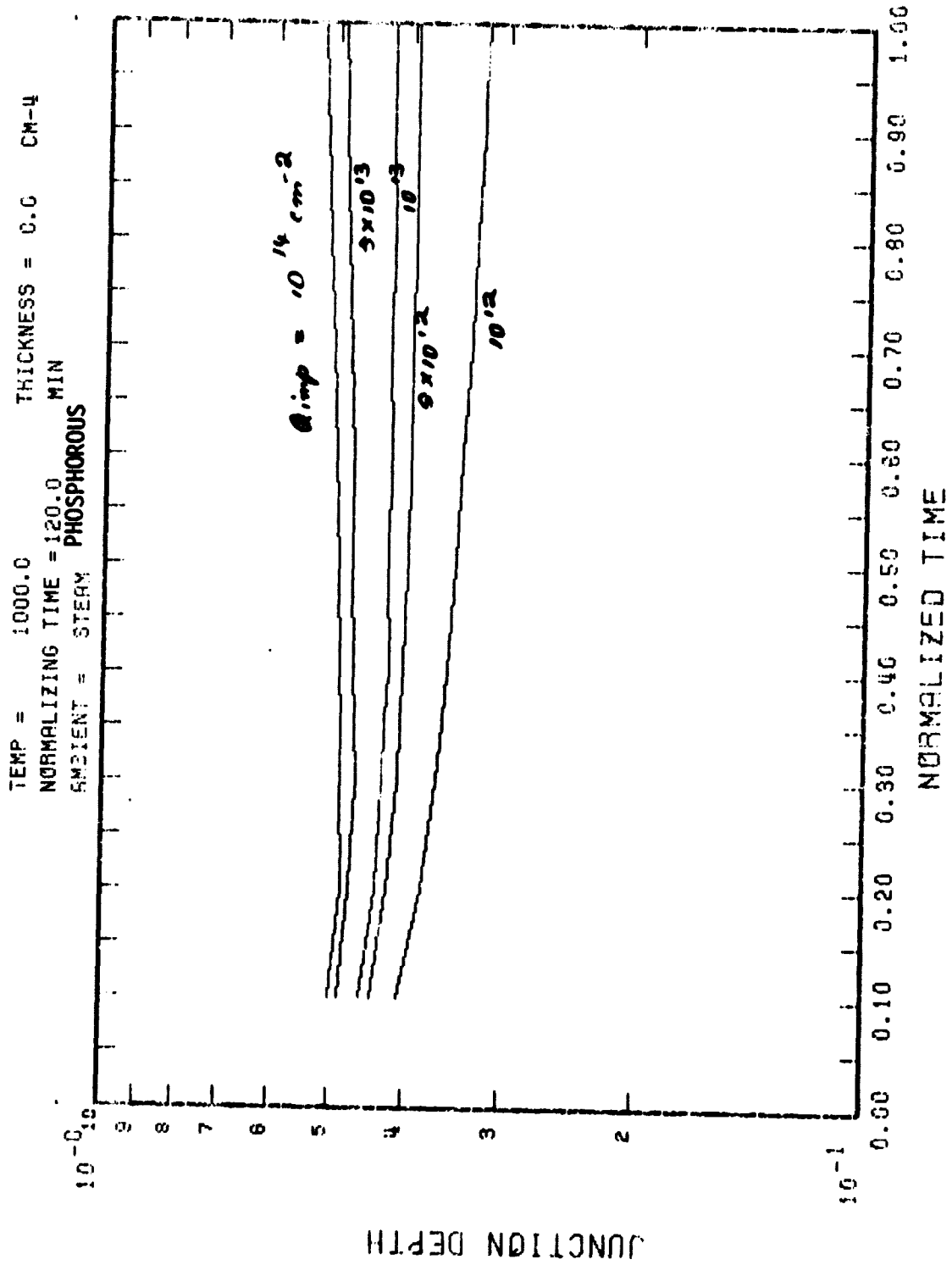
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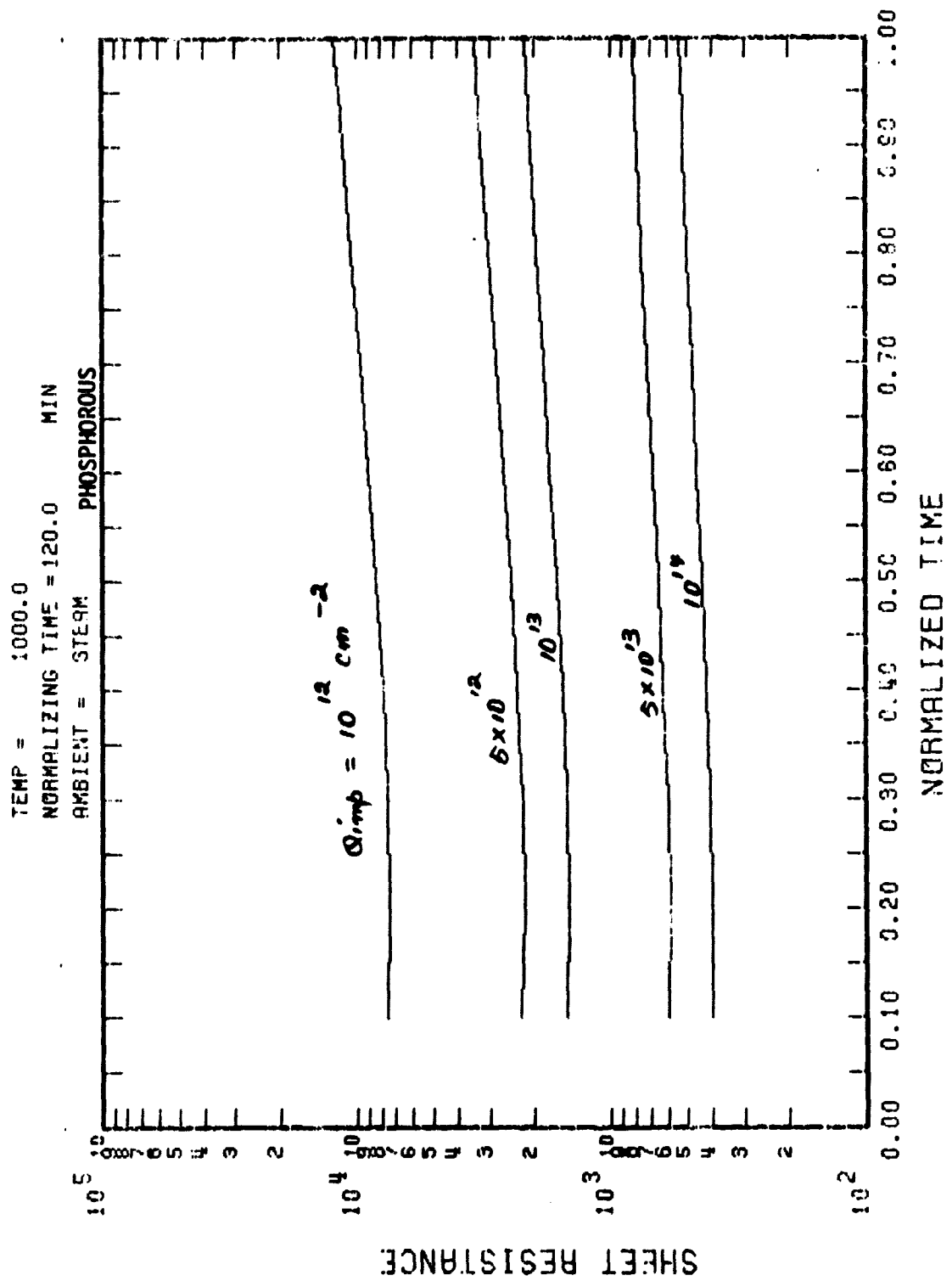
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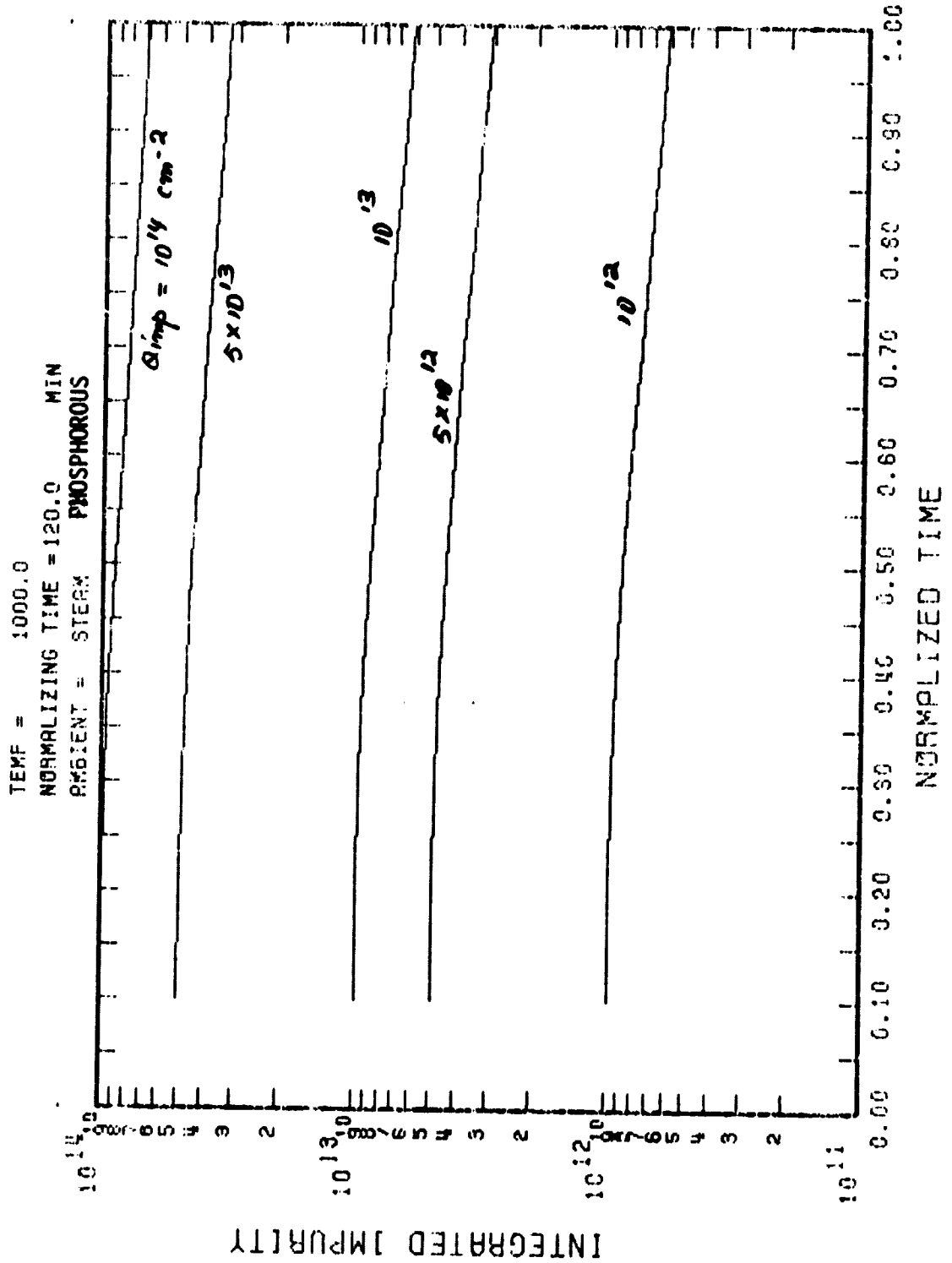


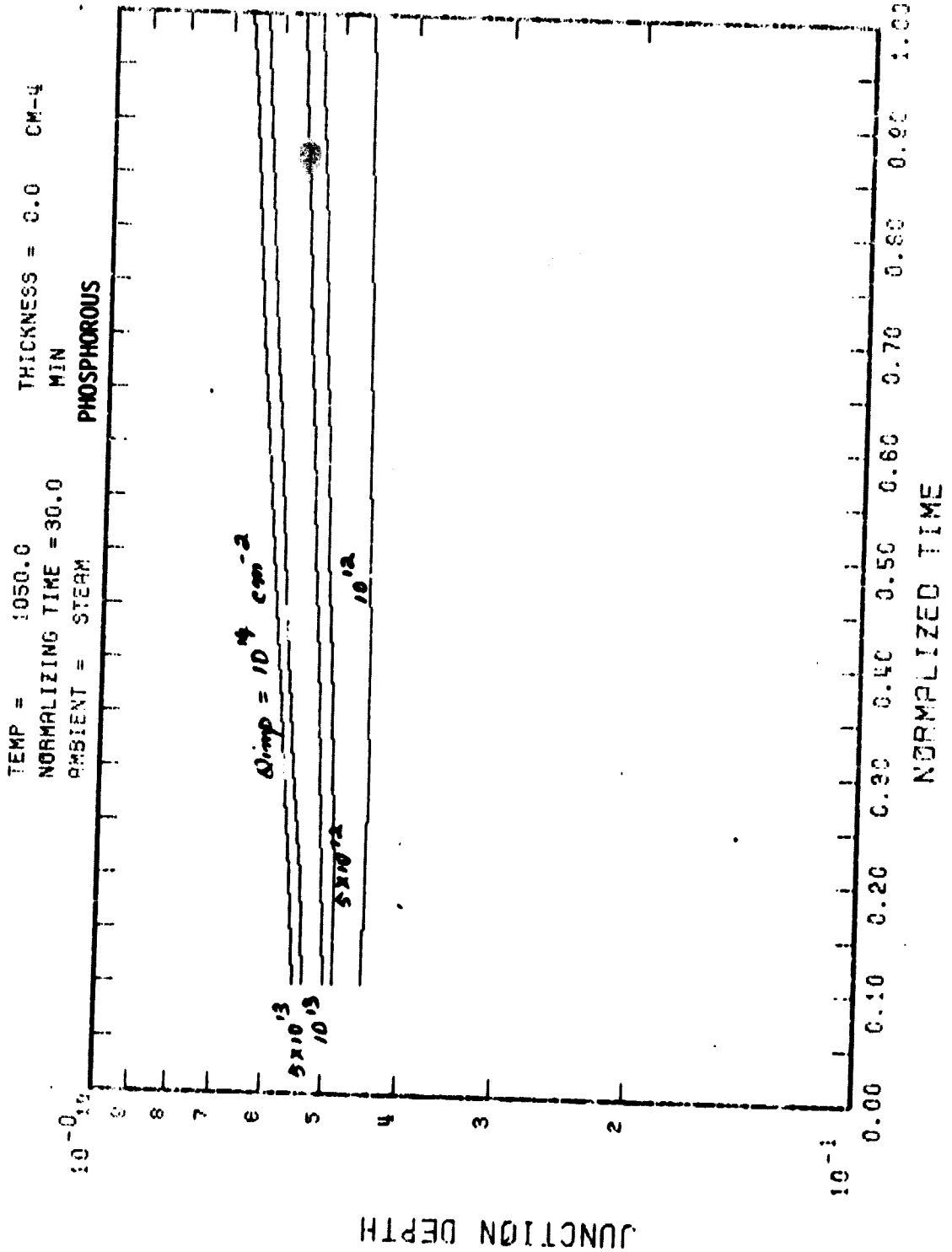




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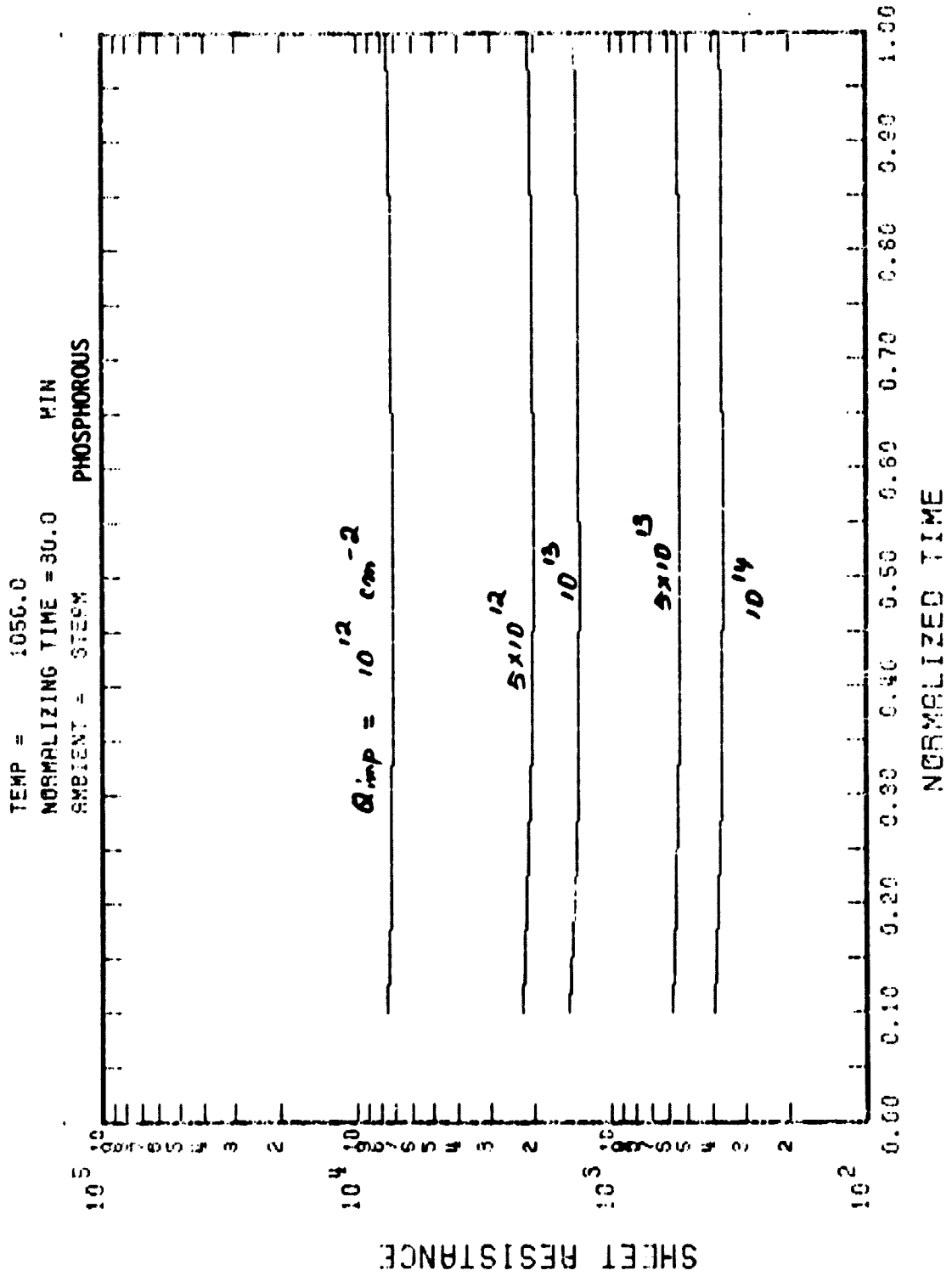


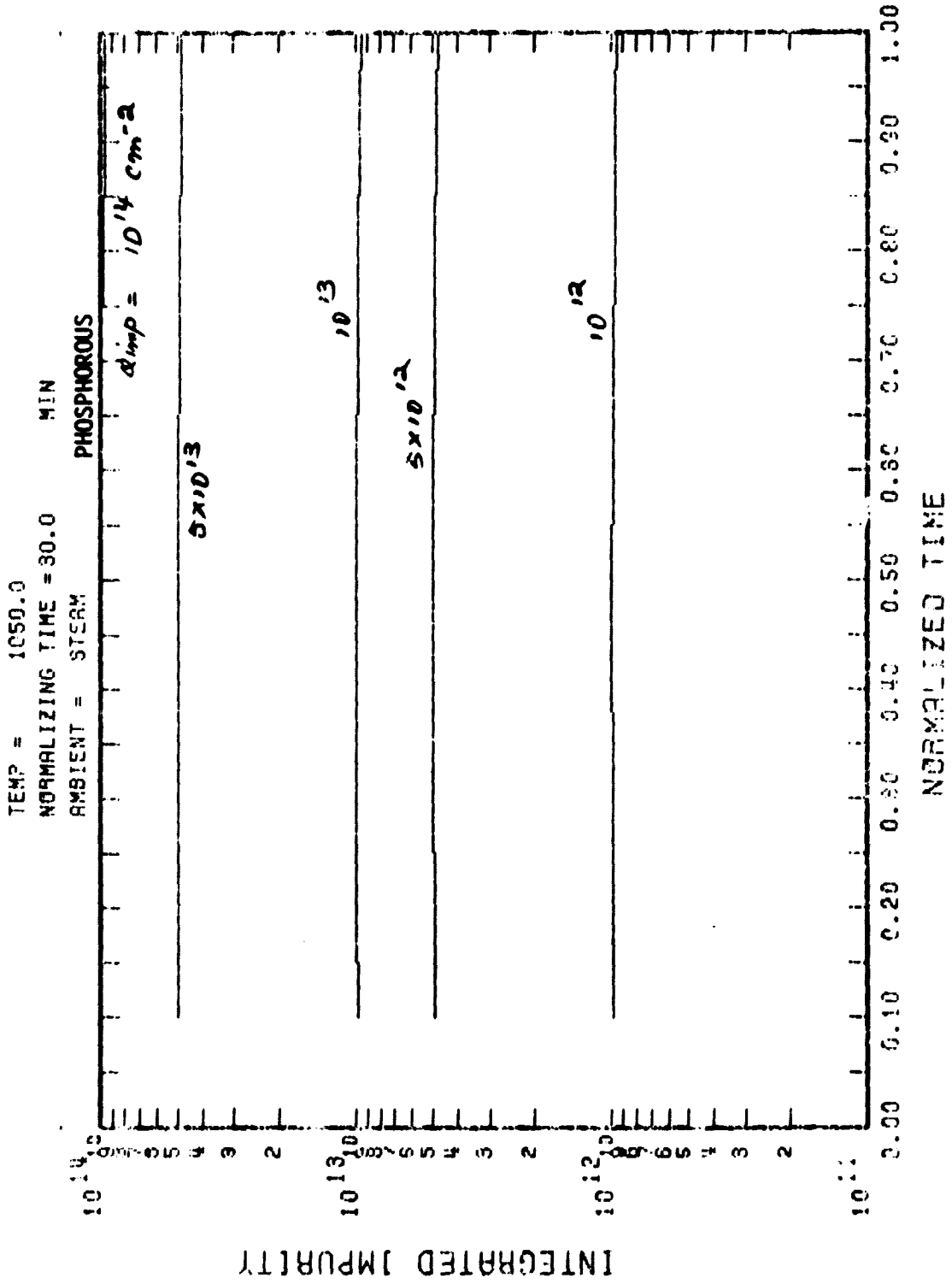


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INTEGRATED IMPURITY

NORMALIZED TIME


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1 C *** SHRFJN PLOT PROGRAM ***
2
3 C
4 C *** DATA DECK ***
5
6 C
7 C *** 1ST CARD
8 NPLT = # OF DATA SET (FOR DIFF. VALUES OF IMPLNT. DOSES)
9 NSTP1 TO NSTP5 = # OF TIME STEPS FOR A VALUE OF NPLT (MAX. 5 VALUES)
10 FIELD #110
11 C
12 C *** 2ND CARD, 4TH AND 6TH CARD
13 IXL, IY = X AND Y AXIS LABELS RESPECTIVELY
14 1ST, 2ND AND 3RD PLOTS ARE NS, X, AND Q VS TIME PLOTS RESP.
15 JCOD = PUT # FOR NO GRID
16 FIELD 2(5A4), 2110
17 C
18 C *** 3RD CARD
19 JGRID = # OF DIV. IN Y AXIS
20 IGRID = # OF DIV. IN X AXIS
21 NSTP = SUBGRID DIV. IN Y AXIS
22 1 GIVES 1 SURGD.
23 NASTP = SUBGRID DIV. IN X AXIS
24 2 GIVES 1 SURGD.
25 YMINV = MIN VAL IN Y AXIS
26 YMAXV = MAX VAL IN Y AXIS
27 XMINV = MIN VAL IN X AXIS
28 XMAXV = MAX VAL IN X AXIS
29 C
30 FIELD 110, 4E10, 5
31 DIMENSION NS(10, 100), XJ(10, 100), Q(10, 100), TIME(10, 100)
32 DIMENSION X(10, 100)
33 DIMENSION IX(5), IY(5), IL(2), X0(10, 100)
34 C
35 C *** READ IN DATA
36 READ 100, NPLT, NSTP1, NSTP2, NSTP3, NSTP4, NSTP5
37 DO 10 I=1, NPLT
38 IF(1.FQ.1) NSTP=NSTP1
39 IF(1.FQ.2) NSTP=NSTP2
40 IF(1.EQ.3) NSTP=NSTP3
41 IF(1.FQ.4) NSTP=NSTP4
42 IF(1.FQ.5) NSTP=NSTP5
43 DO 10 J=1, NSTP
44 READ(14, 104) JMAX, IAMBNT
45 READ(14, 101) TEMP, THAX, DELT, DELY, VDIST
46 READ(14, 101) NS(1, J), X(1, J), XJ(1, J), Q(1, J), TIME(1, J), X0(1, J)
47 IF(IAMBNT.EQ.1) I(1)= 'DRY OR'
48 IF(IAMBNT.EQ.1) I(2)= 'YGEN'
49 IF(IAMBNT.EQ.2) I(1)= 'STEAM'
50 IF(IAMBNT.EQ.2) I(2)= '
51 IF(IAMBNT.EQ.3) I(1)= 'NITROG'
52 IF(IAMBNT.EQ.3) I(2)= 'EN'
53 C
54 100 FORMAT(8I10)
55 101 FORMAT(1H0, 4E15, 9)
56 102 FORMAT(2(5A4), 2110)
57 103 FORMAT(4I10, 4E10, 4)
58 104 FORMAT(1H0, 8I10)
59 105 FORMAT(2A4)
60 400 FORMAT(1H0, 10X, 'XMIN = ', 5X, 'XMAX = ', 5X, 'YMIN = ', 5X, 'YMAX = ',
61 //1H0, 3X, 4(F10.5, 74))
62 C
63 DATA WGT, XMAX, YMAX/0.0075, 7.0, 5.0/
64 THAX=THAX/47.
65 IC=10
66 C
67 C *** INITIATE THE PLOT
68 DO 11 N=1, 3
69 READ 102, (IX(I), I=1, 4), (IY(I), I=1, 5), JCOD
70 READ 103, IGRID, JGRID, NSTP, NASTP, YMINV, YMAXV, XMINV, XMAXV
71 PRINT 400, XMINV, XMAXV, YMINV, YMAXV
72 IF(JCOD.NE.0) ICOD=2
73 IF(JCOD.EQ.0) ICOD=3
74 CALL PLOTS(10, 0, 10, 3)
75 CALL PLOT(1, 5, 1, 0, -3)
76 C
77 C *** DRAW BORDER
78 CALL PLOT(0, 0, YMAX, 2, -1)
79 CALL PLOT(XMAX, YMAX, 2, -1)
80 CALL PLOT(XMAX, 0, 2, -1)
81 CALL PLOT(0, 0, 2, -1)
82 C
83 C *** DRAW GRID
84 YDIV=YMAX/FLOAT(JGRID)
85 JK=1
86 DO 12 I=1, JGRID
87 DO 13 J=1, IC*NSTP
88 VSPC=ALOG10(FLOAT(J*JK))+YDIV

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```

CALL PLOT(0.0,YSPC,3)
CALL PLOT(0.12,YSPC,2.0)
CALL PLOT(XMAX=0.12,YSPC,1.00)
13 CALL PLOT(XMAX,YSPC,2.0)
12 JK=JK+10
IGRID1=IGRID+NXSTP
IGRID2=IGRID1-1
XDIV=XMAX/FLOAT(IGRID1)
DO 14 I=1,IGRID2
XSPC=FLOAT(I)*XDIV
CALL PLOT(XSPC,0.0,3)
CALL PLOT(XSPC,0.12,2.0)
CALL PLOT(XSPC,YMAX=0.12,1.00)
C 14 CALL PLOT(XSPC,YMAX,2.0)
** ARG NUMBERS
VAL1=YMINV
JK=1
JGRD1=JGRID+1
DO 15 I=1,JGRD1
DO 17 J=1,IC,NYSTP
IF(I.EQ.JGRD1.AND.J.NE.1) GO TO 17
YSPC=ALOG10(FLOAT(J*JK)*YDIV)
YSPC1=YSPC
IF(J.EQ.1) GO TO 200
VAL=FLOAT(I)
CALL NUMBER(-0.18,YSPC1,.09,VAL.N.-1)
GO TO 17
200 VAL2=ALOG10(VAL)
CALL NUMBER(-0.56,YSPC1,0.10,10.0.-1)
CALL NUMBER(-0.36,YSPC1,0.09,0.1,VAL2.0.-1)
17 CONTINUE
VAL=VAL1*IN.
16 JK=JK+10
XV=XMAXV/FLOAT(IGRID)
IGRID3=IGRID+1
DO 18 I=1,IGRID3
XSPC=(I-1)*XDIV*NTSTP
XSPC1=XSPC*0.2
VAL=XV*(I-1)
C 18 CALL NUMBER(XSPC1,-0.20,0.1,VAL.N.0.2)
** PUT LABELS
CALL SYMBOL(0.8,1.0,0.1313,14.90,.30)
CALL SYMBOL(2.00,0.50,0.1313,14.0,.30)
CALL SYMBOL(2.0,0.5,0.1313,14.0,.30)
CALL NUMBER(3.0,0.5,0.1313,14.0,.30)
CALL SYMBOL(2.0,0.5,0.1313,14.0,.30)
* 0.0,32)
CALL NUMBER(3.4,0.5,0.1313,14.0,.30)
CALL SYMBOL(2.0,0.5,0.1313,14.0,.30)
CALL SYMBOL(3.0,0.5,0.1313,14.0,.30)
IF(N.EQ.2) CALL SYMBOL(4.5,0.5,0.1313,14.0,.30)
* 0.0,23)
IF(N.EQ.2) CALL NUMBER(5.6,0.5,0.1313,14.0,.30)
C ** DRAW CURVES
YLOG=YMAX/FLOAT(JGRID)
XV=XMAX/XMAXV
YHVR=1./YMINV
DO 22 I=1,NPLT
CALL PLOT(0.0,0.0,3)
IF(I.EQ.1) NSTP=NSTP1
IF(I.EQ.2) NSTP=NSTP2
IF(I.EQ.3) NSTP=NSTP3
IF(I.EQ.4) NSTP=NSTP4
IF(I.EQ.5) NSTP=NSTP5
DO 21 J=1,NSTP
IF(J.EQ.1) L=3
IF(J.NE.1) L=2
IF(I.AMNT.NE.3) TIME(I,J)=TIME(I,J)/TIME(NPLT,NSTP)
XMOVE=TIME(I,J)*XV
IF(N.EQ.3) GO TO 201
IF(N.EQ.2) GO TO 202
YMOVE=YLOG*ALOG10(XS(I,J)*YHVR)
GO TO 21
201 YMOVE=YLOG*ALOG10(XS(I,J)*YHVR)
GO TO 21
202 YMOVE=YLOG*ALOG10(XS(I,J)*YHVR)
21 CALL PLOT(XMOVE,YMOVE,L,0)
IF(N.EQ.2) GO TO 22
CALL PLOT(0.0,0.0,3)
DO 23 J=1,NSTP

```

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MIN*

CM=4*

```
160 IF(J.EQ.1) L=3
161 IF(J.NE.1) L=2
162 XMOVE=TIME(1,J)*XV1
163 XI(1,J)=XI(1,J)*(YDIST-0.45*XD(1,J))/1.E-4
164 IF(XI(1,J).LT.1.E-01) XI(1,J)=1.E-01
165 YMOVE=YLOG*ALOG10(XI(1,J)*YHVR)
166 23 CALL PLOT(XMOVE,YMOVE,L,0)
167 22 CONTINUE
168 CALL PLOT(0.,0.,999)
169 11 CONTINUE
170 STOP
171 END
```

MICRON=5nS2(1).PARAM

```

1 SUBROUTINE PARAM(I,T)
2 C.....
3 C AFTER THAI AND MORIN AND MAITA.
4 C.....
5 IMPLICIT DOUBLE PRECISION (A-H,O-Z)
6 CI=1.E15
7 2 FG=1.21*7.1E-10*SQRT(I)*(T)**(-.5)
8 EG=FG/(8.62E-5*(T))
9 CIOLD=CI
10 CI=3.87E16*((T)**(1.5))*EXP(-EG/7.)
11 R=CIOLD/CI
12 IF(R.LT.0.995.AND'R.GT.1.005) GO TO 2
13 RETURN
14 END
15 C.....

```

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1      DOUBLE PRECISION G(CN,JJ)
2      IMPLICIT DOUBLE PRECISION(A-H,O-Z)
3      C.....
4      C      IRWIN'S CONDUCTIVITY FORMULAS.
5      C.....
6      IF(JJ.EQ.1) GO TO 3
7      IF(CN.GT.0.0) A=1.0
8      IF(CN.GT.0.0) B=7.20-17
9      IF(CN.GT.1.50+14) A=0.65
10     IF(CN.GT.1.50+14) B=3.30-11
11     IF(CN.GT.2.40+18) A=0.832
12     IF(CN.GT.2.40+18) B=1.470-14
13     IF(CN.GT.1.50+19) A=0.966
14     IF(CN.GT.1.50+19) B=4.0-17
15     GO TO 5
16     3  IF(CN.GT.0.0) A=1.0
17     IF(CN.GT.0.0) B=2.0-16
18     IF(CN.GT.3.50+15) A=0.837
19     IF(CN.GT.3.50+15) B=6.970-14
20     IF(CN.GT.1.00+17) A=0.543
21     IF(CN.GT.1.00+17) B=6.930-9
22     IF(CN.GT.9.50+18) A=0.94
23     IF(CN.GT.9.50+18) B=2.0-16
24     IF(CN.GT.6.0+19) A=0.744
25     IF(CN.GT.6.0+19) B=1.430-12
26     IF(CN.GT.2.35+20) A=0.456
27     IF(CN.GT.2.35+20) B=1.040-6
28     5  G = B*(CN**A)
29     RETURN
30     END

```

MICRON*SnS2(1).OXDATA

```

1      SUBROUTINE OXDATA(AMNT,ORINT,T,R,C,M,KB)
2      C.....
3      C.....
4      C.....
5      C.....
6      C.....
7      C.....
8      C.....
9      C.....
10     C.....
11     C.....
12     C.....
13     C.....
14     C.....
15     C.....
16     C.....
17     C.....
18     C.....
19     C.....
20     C.....
21     C.....
22     C.....
23     C.....
24     C.....
25     C.....
26     C.....
27     C.....
28     C.....
29     C.....

```

SUBROUTINE FOR OXIDATION PARAMETERS AND SEGREGATION CO-EFFI.

IMPLICIT DOUBLE PRECISION(A-H,O-Z)
INTEGER AMBNT,ORINT
DOUBLE PRECISION KB,M,M1,M3

IF(AMNT.EQ.1) GO TO 12
R=4.40277D-10*DEXP(-7945.74/T)
IF(ORINT.EQ.1) C=4.94558D-1*DEXP(-22184.07/T)
IF(ORINT.EQ.2) C=9.13646D-1*DEXP(-21835.313/T)
IF(ORINT.EQ.3) C=1.600D*DEXP(-22396.838/T)
GO TO 14

12 CONTINUE
R=1.58507D-9*DEXP(-13916.6449/T)
IF(ORINT.EQ.1) C=2.0093D-1*DEXP(-24118.98/T)
IF(ORINT.EQ.2) C=4.33277D-1*DEXP(-24551.98/T)
IF(ORINT.EQ.3) C=7.09845D-1*DEXP(-24957.028/T)

14 CONTINUE
M1=33.3*DEXP(-0.57/(KR*T))
M3=20.0*DEXP(-0.67/(KR*T))
IF(ORINT.EQ.1) M=M1
IF(ORINT.EQ.2) M=(M1+M3)/2.0
IF(ORINT.EQ.3) M=M3
RETURN
END

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```

1 SUBROUTINE FRONT(IMAXI,JMAXI,LM,K,TEMP,DFI,DELT,JSTEP,
2 * KTYPE,KOTI,XDIST)
3
4 C C C C
5 SUR. FOR CALCULATING CONTOUR FRONT MOVEMENT DATA AND
6 READING AND WRITING THE SAME ON FILE
7
8 C
9 IMPLICIT DOUBLE PRECISION(A-H,O-Z)
10 DIMENSION XFRONT(6), YFRONT(6)
11 DATA IDOL,IBLNK,ISTAR,IHS,IM,IMW/
12 IF(KTYPE.NE.1) GO TO 800
13
14 C
15 READ FILE
16 DO 60 KK=1,JSTEP
17 READ (9,390) MARK
18 IF (MARK.NE.IDOL) GO TO 50
19 READ (9,430) TEMP,DFI,DELT
20 READ (9,390) MARK
21 50 READ (9,430) (DIM,L=1,6)
22 READ (9,430) (DIM,L=1,6)
23 READ (9,420) IMAXI,JMAXI,K,LM
24 60 CONTINUE
25 RETURN
26
27 800 CONTINUE
28 DO 260 LL=1,6
29 CONVAL=10.0*FLOAT(70-LL+1)
30 XF=CONDEF(IMAXI,JMAXI,0,-JMAXI,0,0,CONVAL)
31 YF=CONDEF(IMAXI,JMAXI,-2,0,0,0,CONVAL)
32 IF (XF.EQ.0.0) GO TO 250
33 XFRONT(LL)=(XF-FLOAT(K))/(XDIST/FLOAT(IMAXI-1))
34 250 CONTINUE
35 IF (YF.EQ.0.0) GO TO 260
36 YFRONT(LL)=(FLOAT(JMAXI)-YF)/FLOAT(JMAXI-1)
37 260 CONTINUE
38
39 C
40 STORE CONTOUR FRONT MOVEMENT DATA IF IFILE = 1
41
42 MARK=IDOL
43 IF (KOTI.GT.1) MARK=IBLNK
44 WRITE (9,390) MARK
45 IF (KOTI.GT.1) GO TO 270
46 WRITE (9,430) TEMP,DFI,DELT
47 MARK=IBLNK
48 WRITE (9,390) MARK
49 270 WRITE (9,430) (XFRONT(LL),LL=1,6)
50 WRITE (9,430) (YFRONT(LL),LL=1,6)
51 WRITE (9,420) IMAXI,JMAXI,K,LM
52 390 FORMAT (1H0,A6)
53 400 FORMAT (1H .3F10.1)
54 420 FORMAT (1H .4I5)
55 430 FORMAT (1H .6(E14.9,2X))
56 RETURN
57 END

```



```

80      30 CALL PLOT(XI,19.5*DY,12)
81      DO 40 I=19,20
82      YY=(I-1)*DY
83      CALL PLOT(XI,YY,3)
84      40 CALL PLOT(14.*DX,YY,12)
85      C *** PUT SYMBOL
86      CALL SYMBOL(0.5,4.7,0.1313,1A,0.0,33)
87      IF(N.EQ.2) IX=IY
88      CALL SYMBOL(1.6,4.45,0.1313,1X,0.0,14)
89      C *** AXES NUMBERS
90      Y=-0.2
91      DO 50 I=1,11
92      X=FLOAT(I-1)*2.*DX*0.125
93      VAL=FLOAT(I-1)*TAUM/10.
94      50 CALL NUMBER(X,Y,HRT,VAL,0.0,2)
95      X=-0.5
96      DO 60 J=1,21
97      Y=FLOAT(J-1)*DY*.043
98      VAL=FLOAT(J-1)*YDMAX/90.
99      60 CALL NUMBER(X,Y,HRT,VAL,0.0,2)
100     CALL SYMBOL(-.75,2.*.1313,'DISTANCE',90.,8)
101     CALL SYMBOL(2.*-.5.*.1313,'NORMALIZED TIME - TAU',0.,21)
102     DO 70 LL=1,6
103     CALL PLOT(0.0,0.0,3)
104     XMOVE=0.
105     CALL PLOT(TAU,XMOVE,2,0)
106     DO 70 ML=1,JSTEP
107     TAUP=TAU(ML)*XMAX/TAUM
108     XMOVE=XFRONT(ML,LL)*YMAX/YDMAX
109     IF(N.EQ.2) YMOVE=YFRONT(ML,LL)*YMAX/YDMAX
110     IF(TAU.GT.0.0.AND.YMOVE.EQ.0.0.AND.N.EQ.2) GO TO 70
111     IF(N.EQ.2) XMOVE=YMOVE
112     IF(XMOVE.LT.0.) XMOVE=0.C
113     CALL PLOT(TAUP,XMOVE,2,0)
114     70 CONTINUE
115     CALL PLOT(0.,0.,9*9)
116     80 CONTINUE
117     STOP
118     END

```

MICRON*5052(1),SHFILE

```
1 SUBROUTINE SHFILE(TIME,DELTA,DELY,TEMP,THAX,RS,YJI,YJUNC,0
2 * ,JMAXI,YDIST,XO,IAMRNT)
3
4 C
5 C C C
6 C
7 IMPLICIT DOUBLE PRECISION(A-H,O-Z)
8 WRITE(13,200) JMAXI,IAMRNT
9 200 FORMAT(1H0,8I10)
10 WRITE(13,100) TEMP,THAX,DELTA,DELY,YDIST
11 WRITE(13,100) RS,YJI,YJUNC,0,TIME,XO
12 100 FORMAT(1H0,6E15.9)
13 RETURN
14 END
```

MICRON=SOS2(1).OUTPUT

```

1  SURROUTINE OUTPUT(X,Y,IMAXI,JMAXI,K,LM,JJ,TIME,YDIST,
2  *ID,ITIME,XO,PTIME,DTIME,IAMBNT)
3
4  C
5  C
6  C
7  C
8  C
9  C
10  C
11  C
12  C
13  C
14  C
15  C
16  C
17  C
18  C
19  C
20  C
21  C
22  C
23  C
24  C
25  C
26  C
27  C
28  C
29  C
30  C
31  C
32  C
33  C
34  C
35  C
36  C
37  C
38  C

```

```

SURROUTINE OUTPUT(X,Y,IMAXI,JMAXI,K,LM,JJ,TIME,YDIST,
*ID,ITIME,XO,PTIME,DTIME,IAMBNT)

TRANSIENT DATA PRINT OUT

IMPLICIT DOUBLE PRECISION(A-H,O-Z)
COMMON /CON/CB1(64,64)
DIMENSION X(1),Y(1),ID(15),XO(1)
IMAX=IMAXI-1
IMAX2=IMAXI+1
PRINT 106, ID, ITIME
PRINT 100, LM, TIME, PTIME, DTIME, K, X(K), IMAXI, X(IMAXI)
PRINT 101, (N,N=2,IMAXI,2)
PRINT 102, (X(I),I=2,IMAXI,2)
PRINT 105
WI=YDIST-0.45*XO(2)
DO 2 J=JMAXI,1,-1
Q=YDIST-Y(J)
IF(IAMBNT.NE.3) Q=(JMAXI-J)*41./FLOAT(JMAXI-1)
2 PRINT 103, Q,(CB1(I,J),I=2,IMAXI,2)
PRINT 108, (XO(I),I=2,IMAXI,2)
IF(IAMBNT.NE.3) PRINT 109, WI
109 FORMAT(/,1H0,10X,'SI FILM = ',F10.5)
108 FORMAT(1H0,10X,'OXIDE THICKNESS IN CM ',/1H0,13X,11(1PF10.3))
PRINT 104, JJ
100 FORMAT(1H0,10X,12H TIME STEP = ,14,3X,7H TIME = ,F10.3,
*5X,'ELAPSED TIME IN SEC. ',2X,'PREDEP = ',F10.3,2X,'DRIVE IN = ',
* F10.3//
*10X,'OXIDE POSITION'/
*10X,'X( ,12,') = ,E6.2,2X,'X( ,12,') = ,E6.2//)
101 FORMAT(/,1H0, 3H1 = ,6X,12(10))
102 FORMAT(/,1H0,3X,3H1 = ,7X,12(1PF10.3))
103 FORMAT(1H, 2X,'Y= ,1PF7.1,2X,11(1PF10.3))
104 FORMAT(/,1H0,'NO. OF ITERATION = ',15)
105 FORMAT(1H0)
106 FORMAT(1H1,10X,15A4,T90,'TIME',A6)
RETURN
END

```

PRT SOS2.PLOT-CONTOUR,,SUBION,,TRIANG,,ABC,,XYZ,,PLOT,,CONDEP,,MAIN

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11CRDN*5052(1).PLOT-CONTOUR

```

1  SURROUTINE PLTCON(A,CONVAL,NC,IK,JK)
2  C
3  C   ISOCONCENTRATION PLOT SUBPROGRAM /
4  C
5  DIMENSION A(64,64),X(1000,3),Y(1000,3),NV(1000)
6  DIMENSION CS(2,3),CT(2,2,4),OT(2,4),O(4),OS(2,3)
7  DATA ZERO/1.0E-20/
8  DATA ((CS(I,J),J=1,3),I=1,2)/0.5,-1.0,0.5,-0.5,0.0,0.5/
9  DATA ((CT(I,J,K),K=1,4),J=1,2),I=1,2)/1.0,0.0,-1.0,0.0,0.0,1.0,0.0,0.0,0.0,1.0,0.0,0.0/
10 *0.0,-1.0,0.0,0.0,-1.0,0.0,0.0,1.0,1.0,0.0,-1.0,0.0,0.0/
11 DATA ((OT(I,J),J=1,4),I=1,2)/0.0,0.0,1.0,1.0,0.0,0.1,0.1,0.0,0.0/
12 DATA ((OS(I,J),J=1,3),I=1,2)/0.5,1.0,0.0,0.0,0.5,0.0,0.0,0.0/
13 DATA XMAX,YMAX/8.0,4.0/
14 NCM=NC-1
15 CONTUR=ALOG10(CONVAL)
16 C * RESET PEN TO ORIGIN
17 C * CALL PLOT(0,0,0,0,3)
18 C * COMPUTE SCALING FACTORS
19 SCALX=XMAX*1.5/(IK-2)
20 SCALY=YMAX/(JK-1)
21 C * START CONTOUR SEARCH
22 NT=0
23 IL=IK-1
24 JL=JK-1
25 DO 50 I=2,IL
26 DO 50 J=1,JL
27 C * LOCATE SQUARE CROSSINGS
28 II=I-2
29 JJ=J-1
30 B(1)=0.25*(ALOG10(A(I,J))+ALOG10(A(I+1,J))+ALOG10(A(I,J+1))
31 *+ALOG10(A(I+1,J+1)))
32 R(1)=10.0**R(1)
33 R(4)=R(1)
34 C * LOCATE TRIANGLES
35 DO 20 K=1,4
36 NP=1
37 GO TO (21,22,23,24),K
38 R(2)=A(I+1,J)
39 R(3)=A(I,J)
40 GO TO 30
41 R(2)=A(I,J)
42 R(3)=A(I,J+1)
43 GO TO 30
44 R(2)=A(I,J+1)
45 R(3)=A(I+1,J+1)
46 GO TO 30
47 R(2)=A(I+1,J+1)
48 R(3)=A(I+1,J)
49 GO TO 30
50 C * LOCATE INTERSECTIONS
51 DO 30 M=1,3
52 IF (CONVAL.LT.AMIN(B(M),B(M+1)).OR.CONVAL.GT.AMAX(B(M),B(M+1)))
53 * GO TO 35
54 NP=NP+1
55 RR=ALOG10(B(M+1))-ALOG10(B(M))
56 IF (ABS(RR).GT.2*PRO) GO TO 33
57 R=0.5
58 GO TO 34
59 DO 33 CONTUR=ALOG10(R(M))/RR
60 CONTINUE
61 TX=OS(1,M)+CS(1,M)*D
62 TY=OS(2,M)+CS(2,M)*D
63 X(INT+1,NP)=OT(1,K)+CT(1,1,K)*TX+CT(1,2,K)*TY+11
64 Y(INT+1,NP)=OT(2,K)+CT(2,1,K)*TX+CT(2,2,K)*TY+JJ
65 CONTINUE
66 IF (NP.LE.1) GO TO 40
67 NT=NT+1
68 NV(INT)=NP
69 CONTINUE
70 DO 50 CONTINUE
71 C * SCALE POINTS
72 IF (NT.EQ.0) GO TO 80
73 DO 65 K=1,NT
74 NM=NV(K)
75 DO 65 L=1,NM
76 X(K,L)=X(K,L)*SCALX
77 Y(K,L)=Y(K,L)*SCALY
78 CONTINUE
79 C * PLOT CONTOUR

```

```
80      DO 71 K=1,NT
81      NH=NV(K)
82      CALL PLOT(X(K,1),Y(K,1),3)
83      IF (MOD(K,10).EQ.0) CALL SYMBOL(X(K,1),Y(K,1),0,IN,NCM,0,0,-1)
84      DO 71 L=2,NM
85      CALL PLOT(X(K,L),Y(K,L),2)
86      IF (NM.EQ.3) CALL PLOT(X(K,1),Y(K,1),2)
87      71 CONTINUE
88      C 9 MOVE PEN TO ORIGIN
89      80 CALL PLOT(0.0,0.0,3)
90      RETURN
91      END
```

```

MICRON*5NS2(1).TRIDAG
1
2 SUBROUTINE TRIDAG(JF,1)
3 C.....
4 IMPLICIT DOUBLE PRECISION (A-H,O-Z)
5 COMMON /TRI/ A(64),B(64),C(64),D(64),V(64)
6 C
7 DIMENSION GAMMA(64),BETA(64)
8 BETA(JF)=B(JF)
9 GAMMA(JF)=D(JF)/BETA(JF)
10 JFP=JF+1
11 DO 100 I=JFP,L
12 BETA(I)=B(I)-A(I)*C(I-1)/BETA(I-1)
13 GAMMA(I)=(D(I)-A(I)*GAMMA(I-1))/BETA(I)
14 LAST=L-JF
15 V(L)=GAMMA(L)
16 DO 200 K=1,LAST
17 I=L-K
18 200 V(I)=GAMMA(I)-C(I)*V(I+1)/BETA(I)
19 RETURN
20 END

```

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MICRON=5n52(1).SUBION

```

SUBROUTINE SUBION(IMAXI,JMAXI,K,Y,YDIST,CSTOP)
C.....
C SUBROUTINE FOR GENERATING ION IMPLANT DATA
C.....
IMPLICIT DOUBLE PRECISION(A-H,O-Z)
COMMON /CON/CR1(64,64)
DIMENSION Y(1)
ISS=0
JM=JMAXI/2
IF(Y(JM).LT.1.D-3) ISS=1
READ 100,CHAX,RP,DRP,VOLT
100 FORMAT(1E15.6,F10.5)
PRINT 200,CHAX,RP,DRP,VOLT,CSTOP
200 FORMAT(//,1H0,'CHAX = ',E10.5,' CM=3',J2,'RP = ',E10.5,' MICRON';
1H,'DRP = ',E10.5,' MICRON'; 2H,'ION IMPLANTATION WITH
* IONON IMPLANT AT',F10.5,' KEV'.BX,'CSTOP = ',E15.6)
IF(ISS.EQ.1) RP=RP*.A=4
IF(ISS.EQ.1) DRP=DRP*.D=.4
DO 1 J=1,JMAXI
1 CB(1,J)=CHAX*DEXP(-0.5*((YDIST-Y(J)-RP)/DRP)**2)
DO 2 J=1,JMAXI
DO 3 I=2,K
3 CB(1,J)=CB(1,J)
2 CONTINUE
RETURN
END

```

MICRON=5n52(1).ABC

```

SUBROUTINE ABC(IMAXI,JMAXI,X,Y,LM,TIME,K,DFI,TEMP,TMAX,KOTI,XO,
YDIST,IAMBNT)
C.....
C.....
C SUBROUTINE WRITES TRANSIENT DATA ON DATA FILE ON UNIT 11
C.....
DOUBLE PRECISION CR1,X,Y,TIME,TEMP,TMAX,DFI,XO,YDIST
COMMON /CON/CR1(64,64)
DIMENSION XO(1)
DIMENSION Y(1),Y(1)
DATA IDOL,IRLNK/1,5,1H /
KOTI=KOTI+1
MARK=IDOL
IF(KOTI.GT.1) MARK=IRLNK
WRITE(11,400) MARK
400 FORMAT(1H0,A6)
IF(KOTI.GT.1) GO TO 2
WRITE(11,100) DFI,TMAX,TEMP,YDIST
WRITE(11,200) K,IMAXI,JMAXI,IAMBNT
200 FORMAT(1H ,8110)
WRITE(11,100) (X(I),I=2,IMAXI)
WRITE(11,100) (Y(I),I=1,JMAXI)
MARK=IRLNK
WRITE(11,400) MARK
2 CONTINUE
WRITE(11,200) LM
WRITE(11,100) TIME
DO 1 J=JMAXI,1,-1
1 WRITE(11,100) (CR1(I,J),I=2,IMAXI)
WRITE(11,100) (XO(I),I=2,IMAXI)
100 FORMAT(1H ,6E15.9)
PRINT 300, KOTI
300 FORMAT(1H0,10X,'KOTI = ',110/)
RETURN
END

```

MICRON=5052(1),XYZ

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```

SUBROUTINE XYZ(I,MAXI,JMAXI,X,Y,LM,TIME,K,DFI,TEMP,THAX,KNTI,XO,
* YDIST,IAMBNT)
C.....
C
C SUBROUTINE READS THE TRANSIENT DATA FILE ON UNIT 11
C
DOUBLE PRECISION DFI,X,Y,TIME,TEMP,THAX,DFI,XO,YDIST
COMMON /CON/CR1(64,64)
DIMENSION XO(1)
DIMENSION X(1),Y(1)
DATA IDOL,IDLNR/148,14 /
DO 3 KLM=1,KNTI
  READ(11,30) MARK
  IF(MARK.NE.IDOL) GO TO 5
  READ(11,100) DFI,THAX,TEMP,YDIST
  READ(11,200) K,I,MAXI,JMAXI,IAMBNT
  100 FORMAT(IH,5E15.9)
  200 FORMAT(IH,8I10)
  READ(11,100) (X(I),I=2,I,MAXI)
  READ(11,100) (Y(I),I=1,I,JMAXI)
  READ(11,100) MARK
  5 CONTINUE
  READ(11,200) LM
  READ(11,100) TIME
  DO 1 J=JMAXI,1,-1
  1 READ(11,100) (CB(I,J),I=2,I,MAXI)
  READ(11,100) (XO(I),I=2,I,MAXI)
  3 CONTINUE
  400 FORMAT(IHO,A4)
C APPLY PERIODIC B.C.
  IMAX2=IMAXI-1
  IMAX =IMAXI-1
  DO 7 J=1,JMAXI
  7 (CB(I,J)=CB(I,3,J)
  (CB(I,IMAX2,J)=CB(I,IMAX,J)
  RETURN
END

```


MICRON*5n52(1).PLOT

```

1  SUBROUTINE PLOT(CS,IMAXI,JMAXI,N)
2  C.....
3  C
4  C   SUBROUTINE PLOTS THE TWO DIMENSIONAL PROFILE
5  C   IN THE OUTPUT PRINTOUT IF IPLOT = 1
6  C.....
7  C
8  C   DOUBLE PRECISION CBI,CS
9  C   COMMON /CON/CBI(64,64)
10  C   DIMENSION SYMBL(21),ULINE(43)
11  C   DIMENSION IX(32)
12  C   DATA SYMBL/1HA,1H ,1HM,1H ,1MC,1H ,1MD,1H ,1ME,1H ,1MF,1H ,
13  C   *1HG,1H ,1HH,1H ,1MI,1H ,1MJ,1H ,1MK/
14  C   DATA DOT,STAR/1H.,1H./,KP/21/
15  C   DATA IX/6*1H , 1HY,1H ,1HA,1HX,1HI,1HS,9*1H /
16  C   IMAX=IMAXI-1
17  C   PRINT 11
18  C   AT=ALOG10(2.2D11)
19  C   FACT=(ALOG10(CS)-AT)/IFLOAT(KP-11)
20  C   K=0
21  C   DO 2 J=JMAXI,1,-1
22  C   DO 1 I=2,IMAXI
23  C   IF(CBI(I,J).LE.0.0) GO TO 3
24  C   K=((ALOG10(CBI(I,J))-AT)/FACT)+1.0
25  C 3 CONTINUE
26  C   IF(K.LT.1) ULINE(I)=DOT
27  C   IF(K.GE.1.AND.K.LE.KP) ULINE(I)=SYMBL(K)
28  C 1 IF(K.GT.KP) ULINE(I)=STAR
29  C   L=JMAXI-1-J
30  C 2 PRINT 10,IX(L), (ULINE(I),I=2,IMAXI), (ULINE(I),I=IMAXI-2,-1)
31  C   PRINT 12
32  C   PRINT 13
33  C   PRINT 14,SYMBL(KP),CS
34  C   KD=KP-1
35  C   DO 4 I=KD,1,-1
36  C   CBL=10.**((I-1)*FACT+AT)
37  C   CBH=10.**(I*FACT+AT)
38  C 4 PRINT 15, SYMBL(I),CBH,CBL
39  C   PRINT 16
40  C 10 FORMAT(1H ,A1,IX,1H),70A11)
41  C 11 FORMAT(1H1,1HIMPURITY CONCENTRATION PROFILE)
42  C   *1H0,41(1H),///)
43  C 12 FORMAT(1H ,IX,50(1H-)//1H ,15X,'X AXIS')
44  C 13 FORMAT( /,1H0,'SYMBOLIC REPRESENTATION OF CONCENTRATION RANGES,
45  C   *//1H0,T10,'SYMBOL',T30,'CONCENTRATION RANGE'/1H ,T10,6(1H-),T30,
46  C   *19(1H-)/ 1H0,T13,1H.,T29,'ABOVE SURFACE CONC.')
47  C 14 FORMAT(1H ,T13,A1,T29,'AT CS = ',F10.3)
48  C 15 FORMAT(1H ,T13,A1,3X,'LESS THAN',E10.3,3X,'GREATER THAN OR EQUAL T
49  C   *0',F10.3)
50  C 16 FORMAT(1H ,T13,1H.,T29,'BELOW 1.00E11')
51  C   RETURN
52  C   END

```

MICRON.SNS2(1).CONDEP

```

1     FUNCTION CONDEP(M,N,I,J,MIN,MAX,CONVAL)
2     C
3     C
4     C
5     C
6     C
7     C
8     C
9     C
10    C
11    C
12    C
13    C
14    C
15    C
16    C
17    C
18    C
19    C
20    C
21    C
22    C
23    C
24    C
25    C
26    IMPLICIT DOUBLE PRECISION(A-H,O-Z)
27    COMMON /CON/A(64,64)
28    DO 100 I=1,M
29    DO 100 J=1,N
30    IF (A(I,J).LT.1.D-700) A(I,J)=1.D-100
31    ILOG=1
32    IF (I.NE.0) GO TO 10
33    IINC=1
34    IMIN=MIN
35    IMAX=MAX-1
36    IF (MIN.EQ.0) IMIN=1
37    IF (MAX.EQ.0) IMAX=M-1
38    IF (J.LT.0) ILOG=-1
39    JINC=0
40    JMIN=JABS(J)
41    JMAX=JMIN
42    GO TO 20
43    10  CONTINUE
44    JINC=1
45    JMIN=MIN
46    JMAX=MAX-1
47    IF (MIN.EQ.0) JMIN=1
48    IF (MAX.EQ.0) JMAX=N-1
49    IF (I.LT.0) ILOG=-1
50    IINC=0
51    IMIN=IABS(I)
52    IMAX=IMIN
53    20  CONTINUE
54    CONDEP=0.0
55    DO 45 II=IMIN,IMAX
56    DO 40 JJ=JMIN,JMAX
57    IF (CONVAL.LT.AMINI(A(II,JJ),A(II+IINC,JJ+JINC)))
58    1.0R.CONVAL.GT.AMAX(A(II,JJ),A(II+IINC,JJ+JINC)))
59    2GO TO 40
60    IF (ILOG.LT.0) GO TO 30
61    CONDEP=((CONVAL-A(II,JJ))/(A(II+IINC,JJ+JINC)-A(II,JJ)))
62    1+FLOAT(II+IINC+JJ+JINC)
63    RETURN
64    30  CONTINUE
65    CONLOG=ALOG10(CONVAL)
66    CONDEP=((CONLOG-DLOG10(A(II,JJ)))/(DLOG10(A(II+IINC,JJ+JINC))-
67    DLOG10(A(II,JJ))))+FLOAT(II+IINC+JJ+JINC)
68    RETURN
69    40  CONTINUE
70    45  CONTINUE
71    RETURN
72    END

```

ORIGINAL PAGE IS
OF POOR QUALITY

MICRON*SnS2(1).MAIN

```

1 C.....
2 C.....
3 C.....
4 C.....
5 C.....
6 C.....
7 C.....
8 C.....
9 C.....
10 C.....
11 C.....
12 C.....
13 C.....
14 C.....
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16 C.....
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78 C.....
79 C.....

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PROCSIM 11
SOLUTION OF DIFFUSION PROBLEM FOR SILICON ON SAPPHIRE
*** NORMALIZED SOLUTION ***

DATA IS READ FROM DECK IN FOLLOWING SEQUENCE:

FIRST CARD:
LIST - # OF TIME STEPS TO BE SKIPPED WHILE PRINTING
IFILE - PUT 1 TO WRITE ON FILE AND ALSO TO LOCATE
 CONTOUR POSITION, CONTOUR FRONT MOVEMENT DATA IS
 WRITTEN ON UNIT 9 AND CONCENTRATION PROFILE IS
 WRITTEN ON UNIT 11.
LFILE - # OF TIME STEPS TO BE SKIPPED WHILE WRITING ON FILE
IPLOT - PUT 1 TO PLOT PROFILE IN PRINT OUT
IREAD - PUT 1 TO READ DATA FROM FILE
 - PUT 2 TO READ ION IMPLANT DATA AND TO
 DO REDISTRIBUTION.
JSTEP - # OF DATA STEPS TO BE READ FROM FILE IF IREAD = 1
IMAXI, JMAXI - # OF GRID POINTS IN X AND Y DIRECTIONS
 RESPECTIVELY, CHECK DIMENSION BEFORE CHANGING
 FORMAT FIELD - 8110

SECOND CARD:
JSTP - PUT 0 IF CONST. SOURCE DIFF. IS DESIRED.
 - PUT 1 IF REDISTRIBUTION IS DESIRED.
 - PUT 2 IF TWO-STEP DIFF. IS DESIRED.
ORINT - PUT 1 FOR 100 CRYSTAL ORIENTATION
 - PUT 2 FOR 110 CRYSTAL ORIENTATION
 - PUT 3 FOR 111 CRYSTAL ORIENTATION
AMANT - PUT 1 FOR DRY OXYGEN
 - PUT 2 FOR STEAM
 - PUT 3 FOR NITROGEN
 FIELD 3110

THIRD CARD:
CSUR - SUBSTRATE DOPING/1.E15
CS - SURFACE CONCENTRATION/1.E18
TEMP - TEMPERATURE IN DEG. CENT.
TMAX - NORMALIZATION TIME IN SECOND
 THIS HAS NO EFFECT IF LAMDA IS SPECIFIED AS DATA
XDIST, YDIST - WIDTH AND THICKNESS (IN MICRON) OF THE TWO
 DIMENSIONAL REGION IN QUESTION
OXTHIC - WIDTH (IN MICRON) OF THE OXIDE IN THE REGION
DFLT - NORMALIZED TIME STEP
 FORMAT FIELD - 8F10.3

FORTH CARD:
IMTYPE - SPECIFY TYPE OF IMPURITY BY PUTTING N OR P
 NO SPEC. IS NECESSARY IF IT IS BORON
IMPUTY - PUT BORON, ARSENIC, PHOSPHOROUS OR ANY
 OTHER NAME.
EA - ACTIVATION ENERGY OF THE DIFFUSION
 IF BLANK AND BORON DIFF., DATA IS SUPPLIED INTERNALLY
DI - DIFFUSIVITY CONST. OF THE IMPURITY
 IF BLANK AND BORON DIFF., DATA IS SUPPLIED INTERNALLY
 FIELD A4.4A4.2F10.3

FIFTH CARD:
ID - IDENTIFICATION COMMENT TO BE PRINTED ON TOP OF
 PROFILE PRINT OUT
ITEST - PUT 0 TO READ LAMDA FROM DATA DECK
CSTOP - CONCENTRATION/1.E15 AT WHICH SIMULATION STOPS
 WHEN THE LEFT END CORNER OF SILICON AND SAPPHIRE
 INTERFACE REACHES THIS VALUE DURING PREDEP.
 FORMAT FIELD - 15A4.15.F15.9

SIXTH CARD (USE IF ISTEP):
ROTEMP - REDISTRIBUTION TEMPERATURE
ROTMAX - REDISTRIBUTION NORM. TIME
 REDISTRIBUTION FINAL TIME IS 1.
RDDLT - REDISTRIBUTION NORM. TIME STEP.
XOA - REDISTRIBUTION INITIAL OXIDE THICKNESS IN CM

```

80 C** WHERE SURF. CONC. WAS CS
81 C** XOR - REDISTRIBUTION INITIAL OXIDE THICKNESS IN CM
82 C** WHERE SURF. HAS THE THICK OXIDE
83 C** CM - SEGREGATION COEFFICIENT, GENERATED INTERNALLY IF
84 C** IMPURITY IS BORON AND NO VALUE IS GIVEN
85 C** FIELD 6F10.3
86 C**
87 C** SEVENTH CARD(USE WHEN ITEST=0):
88 C** LAMDA = LAMDA**2/1.E-3
89 C** FORMAT FFLD = F10.3
90 C**
91 C** EIGHTH CARD(USE IF IREAD=2):
92 C** ION IMPLANTATION DATA
93 C** CMAX = MAX. CONCENTRATION
94 C** RP = RANGE OF DISTRIBUTION, MEAN VALUE (IN MICRON )
95 C** DRP = STRAGGLE, STANDARD DEVIATION, (IN MICRON )
96 C** VOLT = IMPLANTATION ENERGY LEVEL IN KEV
97 C** FIELD 3E15.6,F10.5
98 C**
99 C*****
100 C
101 C IMPLICIT DOUBLE PRECISION (A-H,O-Z)
102 C INTEGER ORINT,AMBNT
103 C DOUBLE PRECISION KB,NI,LAMDA
104 C COMMON /TRI/ A(64),B(64),D(64),E(64),V(64)
105 C COMMON /CON/ CB1(64,64)
106 C DIMENSION X(64), Y(64), CB(64,64), CB2(64,64), G(64,64), ID(15)
107 C DIMENSION IMTYPE(1), IMPUTY(4), IRRON(4)
108 C DIMENSION XOLAST(4), XO(64), DRXO(64), VP(64)
109 C DIMENSION IMAT(2), IORNT(1), IDOX(2), INIT(2), ISTM(1)
110 C
111 C C
112 C C
113 C DEFINE COMPUTING FUNCTIONS
114 C
115 C RHS(G,G1,G3,C10,C20,C20)=C00*0*(G1*C20*G3*C10)
116 C RATIO(C,CSUR,NI)=(C-CSUB)/(2.*NI)
117 C ROOT(RATIO)=DSQRT((RATIO**2)+1.0)
118 C FU(RATIO,ROOT)=((RATIO+ROOT)**2)/ROOT
119 C CALL ERTRAN (9,DATE,TIME)
120 C
121 C C
122 C READ SIMULATION INITIAL DATA
123 C
124 C READ 360, LIST,IFILE,IFILE,IPLOT,IREAD,JSTEP,IMAXI,JMAXI
125 C READ 360, JSTP,ORINT,AMBNT
126 C IF(IREAD.EQ.2) JSTP=1
127 C READ 370, CSUB,CS,TEMP,TMAX,XDIST,YDIST,OXTHIC,DELT
128 C READ 320, IMTYPE,IMPUTY,EA,DI
129 C READ 380, ID,ITEST,CSTOP
130 C IF (JSTP.GT.0) READ (5,370,ERR=310) RDTEMP,RDTHMAX,RDDLT,XOA,XOB,CM
131 C IF (ITEST.EQ.0) READ (5,370,ERR=310) LAMDA
132 C
133 C C
134 C C
135 C C
136 C C
137 C C
138 C C
139 C C
140 C C
141 C C
142 C C
143 C C
144 C C
145 C C
146 C C
147 C C
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150 C C
151 C C
152 C C
153 C C
154 C C
155 C C
156 C C
157 C C
158 C C
159 C C

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160 NAMELIST /PUT/ LIST,IFILE,LF,LE,I,PLOT,I,READ,JSTEP,IMAX1,JMAX1,JRTP
161 1,ORINT,AMBNT,CSUB,CS,TEMP,TMAX,XDIST,YDIST,OXTHIC,DELT,EA,DI,ITPST
162 2,CSTOP,LAMDA,ROTFMP,ROTHAX,RODLT,XOA,XOB,CM,JLIM,DLIN,TMAX
163 WRITE (4,PUT)
164
165 C C C
166 REFORMATION OF COMPUTING, GEOMETRIC AND PHYSICAL PARAMETERS
167
168 IF (JSTEP.EQ.0.OR.JRTP.GT.1) ICOND=1
169 IF (ICOND.EQ.1) AMBNT=1
170 IF (AMBNT.NE.3) XDIST=XDIST*1.D-4
171 IF (AMBNT.NE.3) YDIST=YDIST*1.D-4
172 IF (AMBNT.NE.3) OXTHIC=OXTHIC*1.D-4
173 JMAX=JMAX1-1
174 KOTI=0
175 IMAX=IMAX1-1
176 IMAX2=IMAX1+1
177 IF (IMAX1.GT.3) GO TO 5
178 DELX=6.DD
179 IF (AMBNT.NE.3) DELX=6.D-4
180 GO TO 6
181 5 DELX=XDIST/FLOAT(IMAX2-3)
182 4 DELY=YDIST/FLOAT(JMAX1)
183 CSUB=CSUB*1.D15
184 CSTOP=CSTOP*1.D15
185 LAMDA=LAMDA*1.D-3
186 CS=CS*1.D18
187 T=TEMP*273.
188 WINDO=(XDIST-OXTHIC)*1.D-5
189 GM=CM
190 CM=1.0
191 TMX=TMAX
192 IF (AMBNT.EQ.1) IMAT(1)=IDOX(1)
193 IF (AMBNT.EQ.1) IMAT(2)=IDOX(2)
194 IF (AMBNT.EQ.2) IMAT=ISTM
195 IF (AMBNT.EQ.3) IMAT(1)=INIT(1)
196 IF (AMBNT.EQ.3) IMAT(2)=INIT(2)
197 IF (ORINT.EQ.1) IORNT='100'
198 IF (ORINT.EQ.2) IORNT='110'
199 IF (ORINT.EQ.3) IORNT='111'
200
201 C C C
202 CALCULATE DISTANCE X AND Y
203
204 DO 10 I=2,IMAX1
205 X(I)=(I-2)*DELX
206 IF (X(I).LE.WINDO) K=1
207 DO 20 J=1,JMAX1
208 Y(J)=(J-1)*DELY
209 DO 30 I=2,IMAX1
210 XOLAST(I)=XOA
211 DO 31 J=JMAX1,1,-1
212 YP(J)=(JMAX1-J)*(1./FLOAT(JMAX1))
213
214 C C C
215 SPECIFY PREDEF CONDITIONS
216
217 DO 40 I=1,IMAX2
218 DO 40 J=1,JMAX1
219 CB(I,J)=0.0
220 CB1(I,J)=0.0
221 CB2(I,J)=0.0
222 DO 50 I=2,K
223 CB(I,JMAX1)=CS
224 CB1(I,JMAX1)=CS
225 CB2(I,JMAX1)=CS
226 TIME=0.0
227 LM=0
228
229 C C C
230 SPECIFY INITIAL PROFILE
231
232 IF (IREAD.EQ.2) CALL SUBION(IMAX1,JMAX1,K,Y,YDIST,CSTOP)
233 IF (IREAD.EQ.1) CALL XYZ (IMFI,JMFI,X,Y,LM,TIME,KA,DFA,TMP,TMX,JS
234 ISTEP,XOLAST,YDIST,AMBNT)
235 IF (IREAD.EQ.1) TMAX=TIME+1.0
236 STIME=TIME
237 IF (JSTEP.EQ.1) ICOND=2
238
239 C C C
240 HEAD CONTOUR FRONT MOVEMENT FROM DATA FILE IF IREAD = 1
241
242 IF (IREAD.EQ.1) CALL FRONT (IMI,JMI,LA,KC,THPR,DFB,DLT,LM,I,KOTI,Y
243 10IST)
244 IF (IREAD.EQ.1) PRINT 430, LM,TIME,TMP,DFA,TMX,IMFI,JMFI,KA

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240      IF (IREAD.EQ.1) PRINT 440, TM, DFB, LA, IMI, JMI
241      IF (IREAD.NE.1) GO TO 60
242      IF (IMF1.NE.IMAX1.OR.JMF1.NE.JMAX1.OR.KA.NE.K) IER=1
243      IF (IMI.NE.IMAX1.OR.JMI.NE.JMAX1.OR.KC.NE.K.OR.LA.NE.LM) IER=1
244      IF (IFR.EQ.1) PRINT 450
245      IF (IER.EQ.1) GO TO 310
246      C
247      C      START SIMULATION STEP
248      C
249      60 IF (ICOND.EQ.1) GO TO 70
250      KOTI=0
251      TEMP=RDTEMP
252      T=TEMP+273.
253      DELT=RODLT
254      TMAX=RODTMAX
255      IF (AMRNT.NE.3) DELT=DELT*TMAX
256      IF (AMRNT.NE.3) TMAX=TMAX
257      TIME=0.
258      70 CONTINUE
259      C
260      C      CALCULATE NI
261      C
262      TMAX=TMAX-DELT
263      CALL PARAM (NI, T)
264      DF=D1*DEXP(-EA/(K*RT))
265      IF (ITEST.NE.0) DF=DF*TMAX/((YDIST*1.D-4)**2)
266      IF (AMRNT.NE.3) DF=DF
267      IF (ITEST.EQ.0) DF=LAMDA
268      IF (ICOND.EQ.1) PRINT 340
269      IF (ICOND.EQ.2) PRINT 350
270      PRINT 390, NI, DF
271      PRINT 420, IMPUTY, TEMP, DF, TMAX
272      C
273      P=(DF*DELT)/(DELY**2)
274      Q=(DF*DELT)/(DELX**2)
275      C
276      C      PRINT INITIAL PROFILE
277      C
278      CALL OUTPUT (X, Y, TMAX, JMAXI, K, LM, JJ, TIME, YDIST, ID, ITIME, XOLAST,
279      * PTIME, DTIME, AMBNT)
280      IF (IREAD.EQ.2.AND.IFILE.EQ.1) CALL ABC (IMAXI, JMAXI, X, Y, LM, TIME, K,
281      I, DF, TEMP, TMAX, KOTI, XOLAST, YDIST, AMBNT)
282      AM=1.0
283      CC=1.0
284      RB=1.0
285      IF (ICOND.NE.1) CALL OXDATA (AMRNT, ORINT, T, BR,
286      I, CC, AM, KB)
287      IF (ICOND.EQ.2.AND.GM.EQ.0) CM =AM
288      IF (ICOND.EQ.2.AND.GM.NE.0) CM =GM
289      IF (ICOND.EQ.2) PRINT 421, IMBT, IORNT, BR, CC, CM
290      C
291      C      START TIME STEP LOOP
292      C
293      80 LM=LM+1
294      C
295      C      STORE N TH. RESULT FOR R.H.S., WILL NOT BE CHANGED DURING ITER.
296      C
297      TIME=TIME+DELT
298      IF (ICOND.EQ.1) STIME=TIME
299      PTIME=TMX*STIME
300      IF (ICOND.EQ.2) PTIME=TMX
301      DTIME=RODTMAX*(TIME-STIME)
302      IF (AMRNT.NE.3) DTIME=TIME
303      DO 90 I=1, IMAX2
304      DO 90 J=1, JMAX1
305      90 CR2(I, J)=CB1(I, J)
306      IF (ICOND.EQ.1) GO TO 110
307      C
308      C      CALCULATE OXIDE THICKNESS
309      C
310      IF (AMRNT.NE.3) GO TO 95
311      DO 94 I=2, IMAX1
312      94 XO(I)=XOLAST(I)
313      GO TO 110
314      95 PS=RB*DELT
315      QS=RR/CC
316      DO 100 I=2, IMAX1
317      XO(I)=XOLAST(I)+PS/((?)*XOLAST(I)+QS)
318      100 DRRXO(I)=(XO(I)-XOLAST(I))/DELT
319      XO(I)=XO(I)

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320 IF((YDIST-0.45*XN(1)).LT.0.1D-4) GO TO 310
321 CONTINUE
322 DELY=(1./FLOAT(JMAX))*YDIST-0.45*XOLAST(2)
323 IF(AMRNT.NE.3) P=DFI*DELT/(DELY**2)
324 JJ=0
325 JM=0
326
327 C
328 C
329 C
330 120 JJ=JJ+1
331 IF (JJ.GT.JLIM) PRINT 400, CTER
332 IF (JJ.GT.JLIM) GO TO 290
333
334 C
335 C
336 C
337 DO 130 I=1,IMAX2
338 DO 130 J=1,JMAX1
339 CR(I,J)=CR(I,J)
340
341 C
342 C
343 C
344 DO 140 I=1,IMAX2
345 DO 140 J=1,JMAX1
346 RA=RATIO(CR(I,J),CSUB,N1)
347 RO=ROOT(RA)
348 G(I,J)=FU(RA,RO)
349
350 C
351 C
352 C
353 DO 220 I=2,IMAX1
354 CALCULATE THE COEFF. IN Y DIRECTION
355 SR=0.
356 DO 150 J=2,JMAX
357 G1=(G(I,J)+G(I+1,J))/2.0
358 G2=(G(I,J)+G(I,J+1))/2.0
359 G3=(G(I,J)+G(I-1,J))/2.0
360 G4=(G(I,J)+G(I,J-1))/2.0
361 IF(AMRNT.EQ.3) GO TO 151
362 SR=0.45*DRRXO(I)*(YP(J)-1.0)*DELT/DELY
363 151 CONTINUE
364 A(J)=-P*G4
365 R(J)=1.+Q*(G1+G3)+P*(G2+G4)+SR
366 D(J)=-P*G2-SR
367 150 E(J)=RHS(Q,G1,G3,CSB(I-1,J),CR2(I,J),CSB(I+1,J))
368
369 C
370 C
371 C
372 PUT BOUNDARY CONDITION ON Y AXIS
373 R(2)=A(2)+R(2)
374 A(2)=0.0
375 IF (ICOND.NE.1) GO TO 170
376 IF (I.GT.K) GO TO 140
377 E(JMAX)=E(JMAX)-D(JMAX)*CS
378 D(JMAX)=0.0
379 GO TO 180
380 160 CONTINUE
381 B(JMAX)=B(JMAX)+D(JMAX)
382 D(JMAX)=0.0
383 GO TO 180
384 170 IF (AMRNT.EQ.3) DRRXO(I)=0.
385 HA=-DELY*(1./CM-0.45)*DRRXO(I)
386 HR=2.*DFI
387 HK1=HA/(HR*G(I,JMAX))
388 HK2=HA/(HB*G(I,JMAX))
389 B(JMAX)=B(JMAX)*((1.+HK2)/(1.-HK1))+D(JMAX)
390 D(JMAX)=0.
391 180 CONTINUE
392
393 C
394 C
395 C
396 CALL TRIDAG (2,JMAX)
397 CONVERT MATRIX SOLUTION
398 DO 190 J=2,JMAX
399 CR(I,J)=V(J)
400 190 CONTINUE
401
402 C
403 C
404 C
405 PUT BOUNDARY VALUES IN Y
406 CR(I,1)=CR(I,2)

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400      IF (ICOND.NE.1) GO TO 210
401      IF (I.GT.K) GO TO 290
402      CR(I,JMAXI)=CS
403      GO TO 220
404      200  CB(I,JMAXI)=CR(I,JMAXI)
405      GO TO 220
406      210  CONTINUE
407      CB(I,JMAXI)=((I+HKZ)/(I+HKI))*CB(I,JMAXI)
408      IF (CR(I,JMAXI).LT.1.D-300) CR(I,JMAXI)=1.D-300
409      220  CONTINUE
C
C
410      PUT BOUNDARY VALUES IN AXIS X(PERIODIC BOUNDARY)
C
C
411      DO 230 J=1,JMAXI
412      CR(I,J)=CB(I,J)
413      230  CB(I,IMAX2,J)=CR(I,IMAX,J)
C
C
414      CHECK FOR CONVERGENCE
C
C
415      IF (JJ.EQ.1) GO TO 120
416      ICK=0
417      DO 240 I=1,IMAXI
418      DO 240 J=1,JMAXI
419      IF (CB(I,J).E.0.D) GO TO 240
420      CTEST=DABS((CR(I,J)-CB(I,J))/CB(I,J))
421      IF (CTEST.LE.DVLM) GO TO 240
422      CTER=DMAXI(CTEST,CTER)
423      ICK=1
424      240  CONTINUE
425      IF (ICK.NE.0) GO TO 120
426      JH=JH+1
427      DO 241 I=1,IMAXI
428      DO 241 J=1,JMAXI
429      IF (CR(I,J).LT.0.D) CB(I,J)=CB(I,J)
430      IF (JH.EQ.1) GO TO 120
C
C
431      PRINT RESULTS
C
C
432      IS=LM/LIST*LIST=LM
433      IF (IS.EQ.0) GO TO 250
434      IF (TIME.GE.TIMAX.AND.CS.NE.0.D) GO TO 250
435      IF (CR(2,1).GE.CSTOP.AND.ICOND.EQ.1) GO TO 250
436      IF (CB(2,1).GE.CSTOP.AND.CS.EQ.0.D.AND.JSTEP.EQ.1) GO TO 250
437      GO TO 240
438      250  CALL OUTPUT (X,Y,IMAXI,JMAXI,K,LM,JJ,TIME,YDIST,IN,ITIME,XO,
439      *PTIME,DTIME,AMBNY)
440      CALL SHREJN (CSUR,YDIST,JMAXI,Y,TIME,DELT,DELT,TEMP,TMAX,IFILF,ITY
441      IPE,AMRNT,XO(2))
442      IF (IPLOT.NE.1) GO TO 260
443      CALL PLOT (CS,IMAXI,JMAXI,K)
C
C
444      STORE TRANSIENT DATA
C
C
445      260  IF (IFILE.EQ.0) GO TO 270
446      IF=LM/LFILE*LFILE=LM
447      IF (IT.EQ.0) GO TO 265
448      IF (TIME.GE.TIMAX) GO TO 265
449      IF (CB(2,1).GE.CSTOP.AND.ICOND.EQ.1) GO TO 265
450      GO TO 266
451      265  CALL ABC(IMAXI,JMAXI,X,Y,LM,TIME,
452      IK,DFI,TEMP,TMAX,KOTI,XO,YDIST,AMRNT)
C
C
453      LOCATE CONTOUR POSITION AND STORE DATA
C
C
454      266  CONTINUE
455      CALL FRONT (IMAXI,JMAXI,LM,K,TEMP,DFI,DELT,JSTEP,D,KOTI,XDIST)
456      270  CONTINUE
C
C
457      GO TO NEXT TIME STEP
C
C
458      IF (CR(2,1).GE.CSTOP.AND.ICOND.EQ.1) GO TO 290
459      IF (TIME.GE.TIMAX) GO TO 290
460      XO(1)=XO(2)
461      DO 280 I=2,IMAXI
462      XOLAST(I)=XO(I)
463      GO TO 80
464      280  IF (JSTEP.GT.1.AND.ICOND.EQ.1) GO TO 300
465      GO TO 310
466      300  TIMAX=TIME+1.

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480          IF (AMNT.NE.3) TIME=TIME+RDTHA
481          ICOND=2
482          GO TO 40
483          310 IF (I.M.EQ.0) PRINT 450
484          STOP
485
C
486          320 FORMAT (A4,4A4,2F10.3)
487          330 FORMAT (1H0,20X,'IMPURITY = ',4A4,2X,'IMPURITY TYPE = ',A4)
488          340 FORMAT (1H0,20X,'*** PREDEPOSITION CYCLE ***')
489          350 FORMAT (1H1,20X,'*** REDISTRIBUTION CYCLE ***')
490          360 FORMAT (8I10)
491          370 FORMAT (8E10.5)
492          380 FORMAT (15A4,15,F15.9)
493          390 FORMAT (//,1H0,10X,'NI = ',D10.3,5X,'DFI = ',D10.3//)
494          400 FORMAT (//,1H0,10X,'ITERATION DID NOT CONVERGE, ERROR = ',D10.3)
495          410 FORMAT (1H1,10X,'*** SOLUTION OF DIFFUSION PROBLEM FOR SILICON,
1 ON SAPPHIRE ***//1H0,31X,'NORMALIZED SOLUTION'//1H,10X,15A4//)
496          2H0,10X,'FOLLOWING ARE THE DATA VALUES')
497          420 FORMAT (//,1H0,10X,'NI - INTRINSIC CARRIER CONC.//1H,10X,'DFI =
1,1H INTRINSIC DIFFUSIVITY OF ',1X,4A4,2X,'AT ',2X,F10.3,2X,'DEG. CENT.
2,//1H,10X,'LAMBDA = LAMBDA**2 = OFI*TMAX/LYMAX',E4.0,21//1H,10X,
3,LAMBDA = ',D10.3,5X,'FOR NORMALIZATION TIME = ',E12.6,2X,'SEC.')
498          421 FORMAT (//,1H0,10X,'AMBIENT = ',2A4/1H0,5X,'CRYSTAL ORIENTATION = '
0A//1H0,5X,'OXIDATION PARAMETERS:',5X,2X,'B = ',
0E10.3,2X,'C = ',F10.3./
0H0,5X,'SEGREGATION COEFF. = ',E10.3)
499          430 FORMAT (1H0,10X,'*** INITIAL PROFILE AT TIME STEP = ',15.2X,'TIME
1 = ',D10.3,2X,'HAS BEEN READ IN FROM DATA FILE 11 ***//1H0,15X,'FOI
500          2LOWING DATA ARE PROVIDED'//1H,15X,'TEMP = ',D10.3,2X,'LAMBDA**2 =
501          3 ',D10.3,2X/1H,10X,'NORM. TIME = ',D10.3,2X,'IMAXI = ',110.2X,'JM
502          4AXI = ',110.2X,'OXIDE GRID = ',16)
503          440 FORMAT (1H0,10X,'*** FOLLOWING DATA ARE OBTAINED FROM THE DATA
504          1 FILE 9 ***//1H,10X,'TEMP = ',F10.3/1H,10X,'LAMBDA**2 = ',D10.
505          23/1H,10X,'TIME STEP = ',110/1H,10X,'IMAXI = ',15/1H,10X,'JMAXI
506          3 = ',15)
507          450 FORMAT (1H0,10X,'***DATA INPUT ERROR ***//1H0,8X,'RUNSTREAM TERMIN
508          1ATED')
509
C
510          END
511
512
513
514
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518

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GPRT S059.SWREJN,MAIN-PLOT

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MICRON=5052(1).SHRFJN
1  SUBROUTINE SHREJN(CSUR,YDIST,JMAXI,X,TIME,DELT,DELY,
2  * TEMP,TMAX,IFILE,ITYPE,IAMBNT,XO)
3  C.....
4  C..... SURROUTINE FOR CALCULATING SHEET RESISTANCE AND JUNCTION
5  C.....
6  IMPLICIT DOUBLE PRECISION(A-H,O-Z)
7  COMMON /CDN/C(64,A4)
8  DIMENSION CNET(64),CRI(64),X(1),Y(64)
9  DEL=YDIST/FLOAT(JMAXI-1)
10 IF(IAMBNT.NE.3) DEL=DEL/YDIST
11 YWJ=0.0
12 YWJ1=0.0
13 DO 4 I=1,JMAXI
14 IJ=JMAXI-I+1
15 Y(I)=YDIST-X(IJ)
16 6 IF(IAMBNT.NE.3) Y(I)=(I-1)*(1./FLOAT(JMAXI-1))
17 JN1=1
18 ICK=0
19 DO 5 J=JMAXI,1,-1
20 I=JMAXI+1-J
21 CRI(I)=C(2,J)
22 IF(CRI(I).LT.CSUR.AND.ICK.EQ.0) JN1=1
23 IF(CBI(I).GT.CSUB) ICK=1
24 IF(CBI(I).GT.CSUR) JN=1
25 5 CNET(I)=CBI(I)-CSUB
26 IF(JN1.EQ.1.OR.JN.EQ.(JMAXI-1).OR.JN.EQ.JMAXI) GO TO 7
27 YWJ=(YDIST/(JMAXI-1))*(CBI(JN)-CSUB)/(CBI(JN)-CBI(JN+1))
28 IF(IAMBNT.NE.3) YWJ=YWJ/YDIST
29 YWJ1=DEL*(CSUB-CRI(JN1))/(CBI(JN1+1)-CBI(JN1))
30 K=0
31 SIGMA=0.000
32 Q=0.00
33 C
34 C
35 C
36 C
37 1 K=K+1
38 IF(K.GE.JMAXI) GO TO 2
39 Q=Q+(CBI(K+1)+CBI(K))*DEL/2.0
40 IF(K.LE.JN1.OR.K.GE.JN) GO TO 1
41 SIG1=G(DABS(CNET(K)),ITYPE)
42 SIG2=G(DABS(CNET(K+1)),ITYPE)
43 SIGMA=SIGMA+(Y(K+1)-Y(K))*((SIG2+SIG1)/2.000)
44 GO TO 1
45 2 CONTINUE
46 IF(JN.EQ.JMAXI) YWJ=0.0
47 IF(JN1.EQ.1.AND.CRI(JN1).GT.CSUR) YWJ1=0.0
48 SIGA=G(DABS(CNET(JN+1)),ITYPE)
49 SIGB=G(DABS(CNET(JN1)),ITYPE)
50 SIGC=G(DABS(CNET(JN1+1)),ITYPE)
51 YJUNC=Y(JN)+YWJ
52 SIGIN=G(DABS(CNET(JN)),ITYPE)
53 SIGWJ=0.5*(YWJ*(SIGIN,SIGA)+(DEL-YWJ1)*(SIGB,SIGC))
54 YWJ1=Y(JN1)+YWJ1
55 SIGMA=SIGMA+SIGWJ
56 RS=1.000/SIGMA
57 WRITE(6,203) YWJ1,YJUNC,RS,Q
58 203 FORMAT(1,5X,' JUNCTION IS AT ',2D15.9,' CM',5X,/,
59 * 5X,' SHEET RESISTANCE = ',D15.9,3X,/,
60 * 5X,' INTEGRATED IMPURITY = ',D15.9)
61 WRITE(6,201) JN1,JN
62 201 FORMAT(10,5X,' JN = ',2I5/)
63 AFAC=1.0
64 IF(IAMBNT.NE.3) AFAC=(YDIST-0.45*X0)/;.D=4
65 YJUNC=YJUNC*AFAC
66 RS=RS/(AFAC*1.0-4)
67 Q=Q*AFAC*1.0-4
68 IF(IFILE.EQ.1) CALL SWFILE(TIME,DELT,DELY,TEMP,
69 * TMAX,RS,YWJ1,YJUNC,Q,JMAXI,YDIST,XO,IAMBNT)
70 RETURN
71 END

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80      DO 30 I=1,19
81      X=0.4*FLOAT(I)
82      LNWT=3
83      IF (MOD(I,5).EQ.0) LNWT=1
84      CALL PLOT(X,0.0,3)
85      CALL PLOT(X,YMAX,2;LNWT)
86      CONTINUE
87      C 30 * HORIZONTAL AXIS NUMBERS
88      DEX=XP/20.
89      IE=21
90      IG=1
91      IF (DEX.LT.0.1) IE=11
92      IF (DEX.LT.0.1) IG=2
93      IF (DEX.LT.0.01) DEX=XP/10.
94      IF (IAMBNT.EQ.3) GO TO 31
95      IG=1
96      DEX=XP/20.
97      IE=21
98      31 CONTINUE
99      DO 40 I=1,IE
100     VAL=DEX*FLOAT(I-1)
101     X=0.4*FLOAT(I-1)-1.5*HGT+0.04
102     Y=0.2
103     CALL NUMBER(X,Y,HRT,VAL,0.0,16)
104     CONTINUE
105     C 40 * VERTICAL AXIS NUMBERS
106     IF (IAMBNT.NE.3) YAK=YC(JK)/1.E-4
107     DEY=YAK/10.
108     DO 50 I=1,11
109     VAL=DEY*FLOAT(I-1)
110     X=-3.0*HGT+0.1
111     Y=YMAX-0.4*FLOAT(I-1)-0.5*HGT
112     CALL NUMBER(X,Y,HGT,VAL,0.0,1)
113     50 CONTINUE
114     CALL SYMBOL(4.2,5.7,0.1,-1.0E20,0.0,0.8)
115     CALL SYMBOL(4.2,5.5,0.1,-1.0E19,0.0,0.8)
116     CALL SYMBOL(4.2,5.3,0.1,-1.0E18,0.0,0.8)
117     CALL SYMBOL(4.2,5.1,0.1,-1.0E17,0.0,0.8)
118     CALL SYMBOL(4.2,4.9,0.1,-1.0E16,0.0,0.8)
119     CALL SYMBOL(4.2,4.7,0.1,-1.0E15,0.0,0.8)
120     CALL SYMBOL(4.0,5.7,0.1,0.0,0.0,-1)
121     CALL SYMBOL(4.0,5.5,0.1,1.0,0.0,-1)
122     CALL SYMBOL(4.0,5.3,0.1,2.0,0.0,-1)
123     CALL SYMBOL(4.0,5.1,0.1,3.0,0.0,-1)
124     CALL SYMBOL(4.0,4.9,0.1,4.0,0.0,-1)
125     CALL SYMBOL(4.0,4.7,0.1,5.0,0.0,-1)
126     CALL SYMBOL(0.0,5.4,0.2,0.0,0.0,-1) = '.0.0.14)
127     CALL SYMBOL(0.0,5.4,0.2,41.0,0.0,-1)
128     CALL SYMBOL(0.0,5.4,0.2,1.0,0.0,-1)
129     CALL NUMBER(2.6,5.4,0.2,DP1,0.0,4)
130     CALL SYMBOL(0.0,5.1,0.2,'TEMPERATURE' = '.0.0.14)
131     CALL NUMBER(2.6,5.1,0.2,TEMP,C,0.0)
132     CALL SYMBOL(0.0,4.8,0.2,'TIME STEP' = '.0.0.14)
133     TLM=LH
134     CALL NUMBER(2.6,4.8,0.2,TLM,0.0,-1)
135     CALL SYMBOL(0.0,4.5,0.2,'TIME' = '.0.0.14)
136     CALL NUMBER(2.6,4.5,0.2,TIME,0.0,2)
137     DO 200 II=1,6
138     CONVAL=10.0*FLOAT(20-II+1)
139     CALL PLYCONICB,CONVAL,II,IK,JK)
140     200 CONTINUE
141     CALL PLOT(0.0,0.0,999)
142     100 CONTINUE
143     STOP
144     END

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OF IN